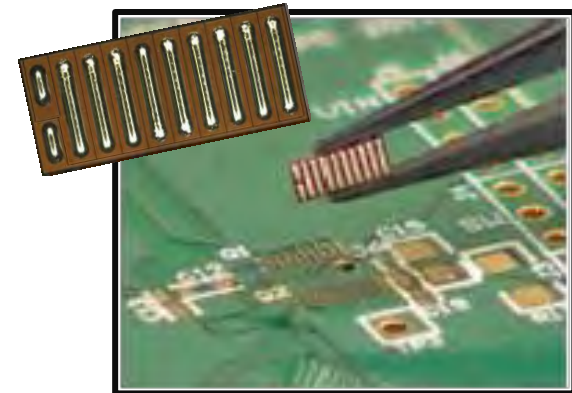


GaN Transistors for Efficient Power Conversion

Alex Lidow
and David Reusch
Efficient Power Conversion

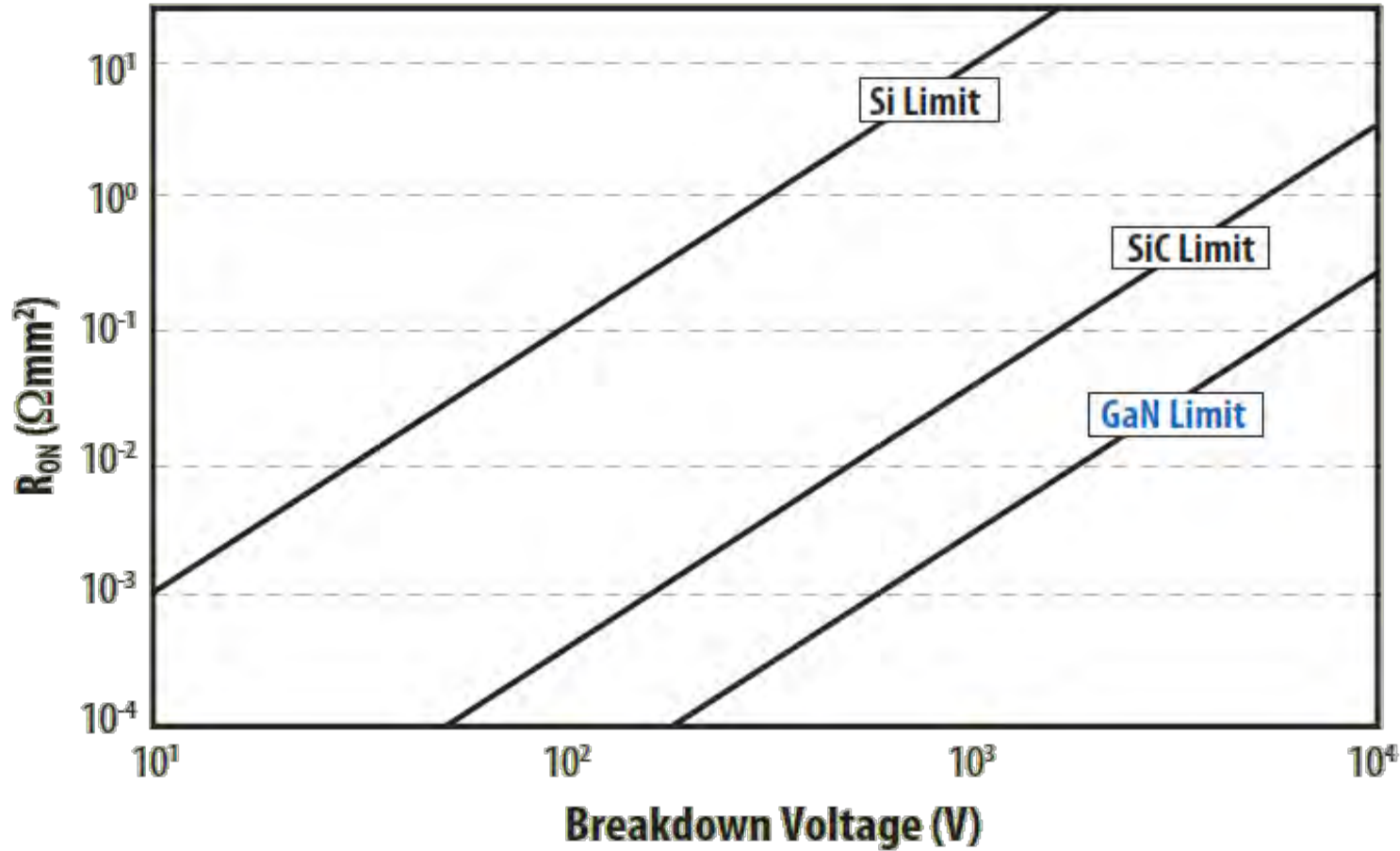


- How GaN works and the state-of-the-art
- Design Basics
- Design Examples
- What is in the future?

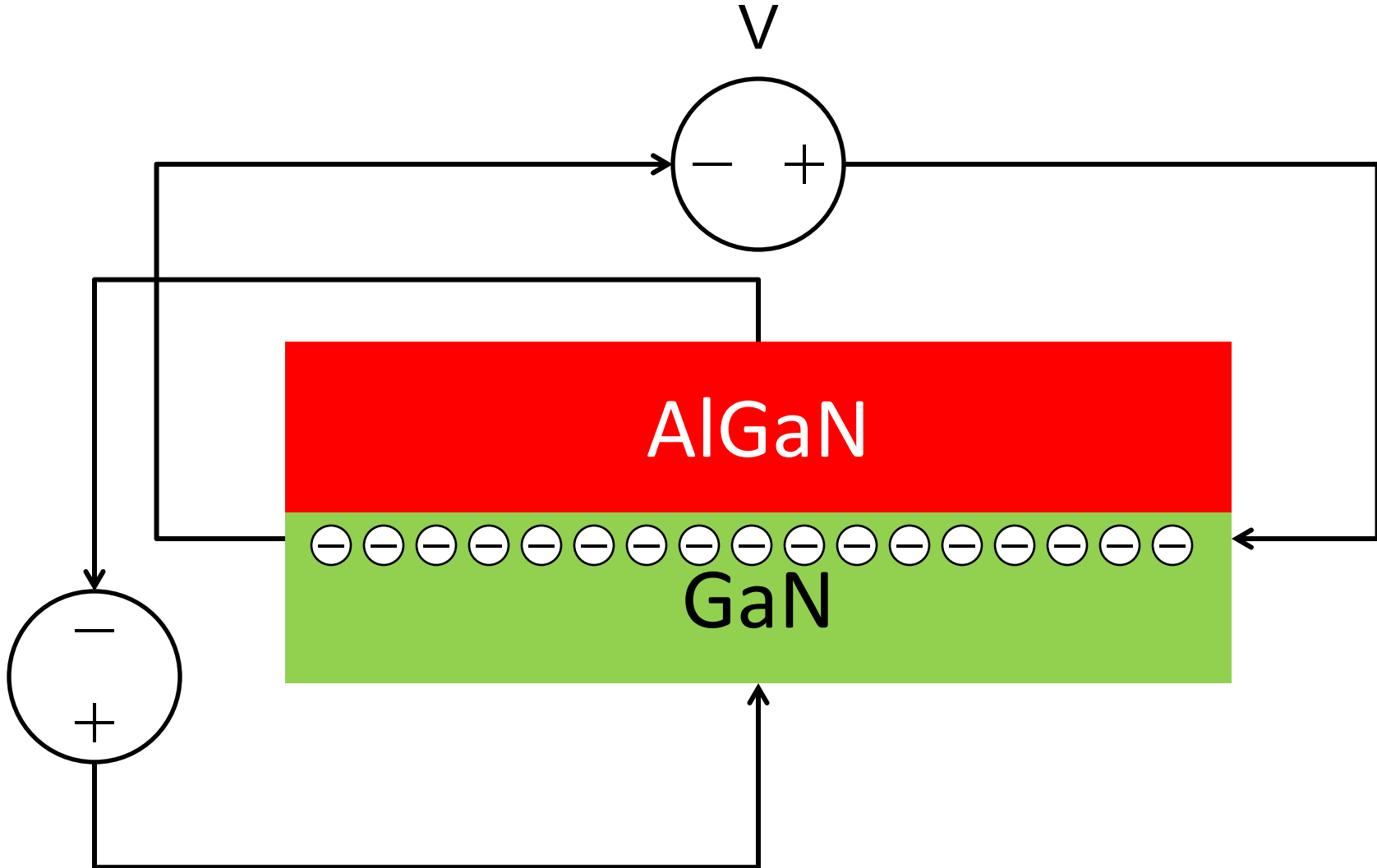
How GaN Works and the State-of-the-Art

- Lower On-Resistance
- Faster
- Less Capacitance
- Smaller
- Lower Cost

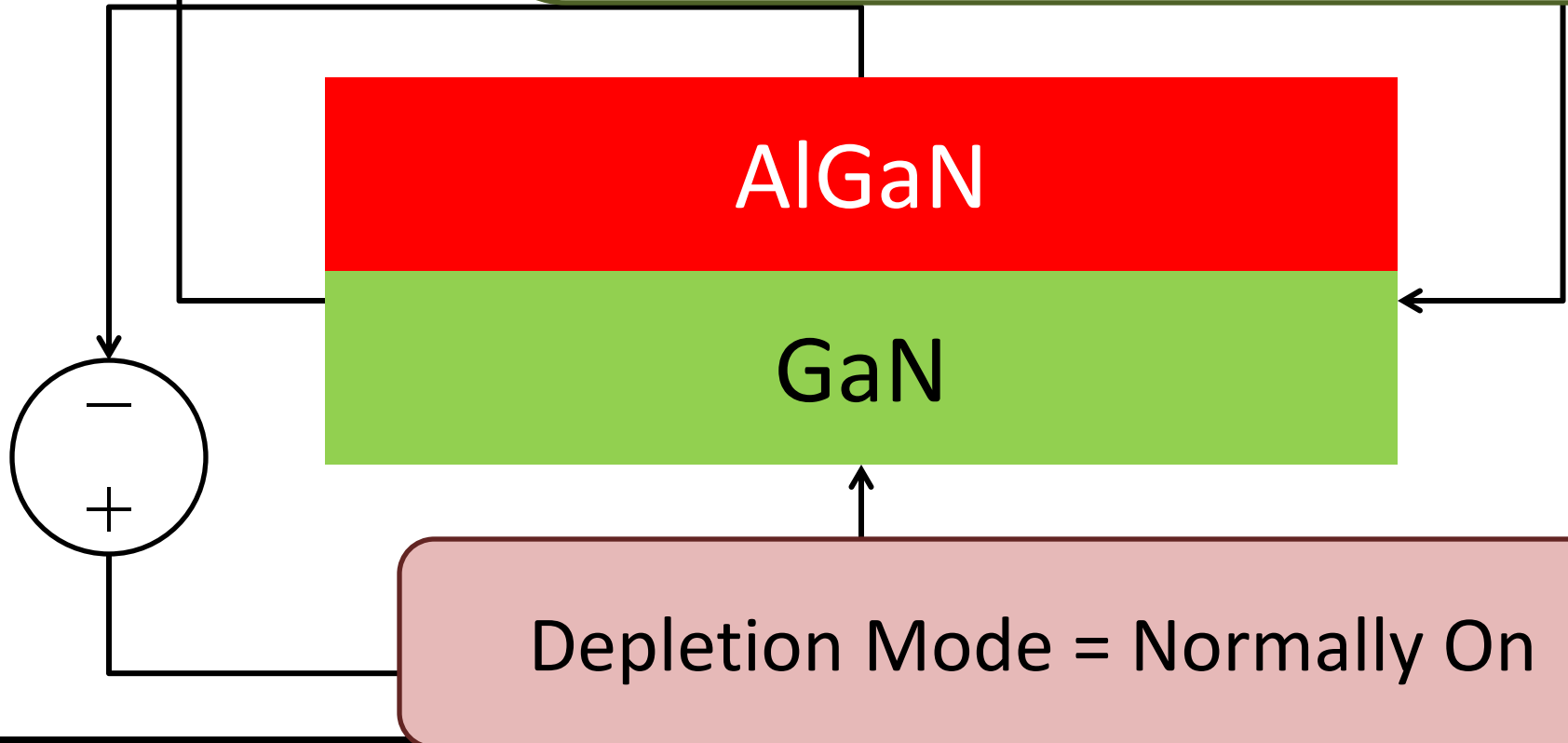
Parameter		GaN	Silicon	SiC
Band Gap E_g	eV	3.2	1.12	3.4
Breakdown Field E_{BV}	MV/cm	3.3	0.3	3.5
Electron Mobility μ_n	$\text{cm}^2/\text{V}\cdot\text{s}$	2000	1500	650

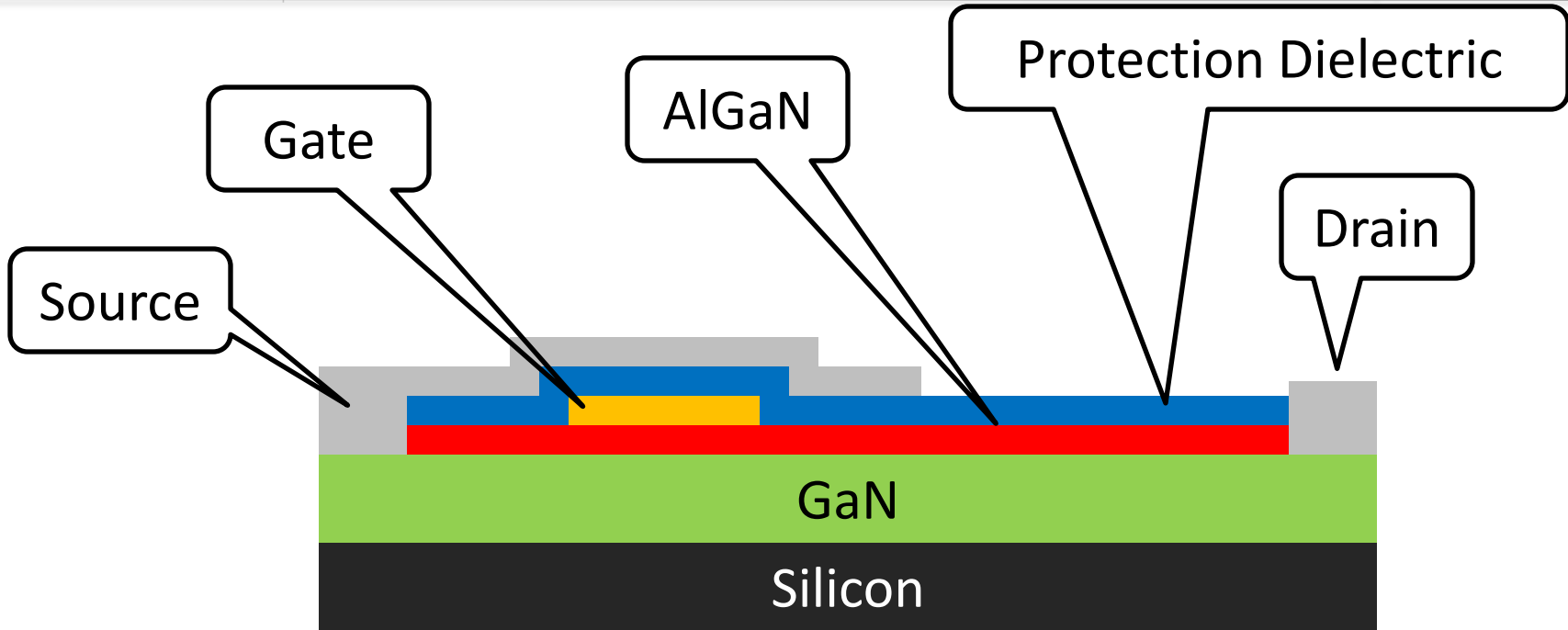


Theoretical on-resistance vs. blocking voltage capability for silicon, silicon carbide, and gallium nitride.

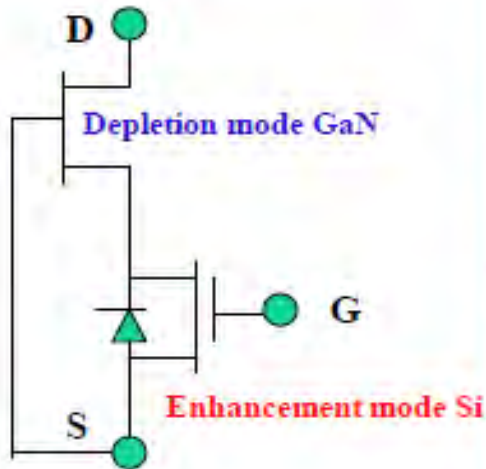


Now we have a switch
That has high voltage blocking
capability,
low on resistance, and is
very, very fast.

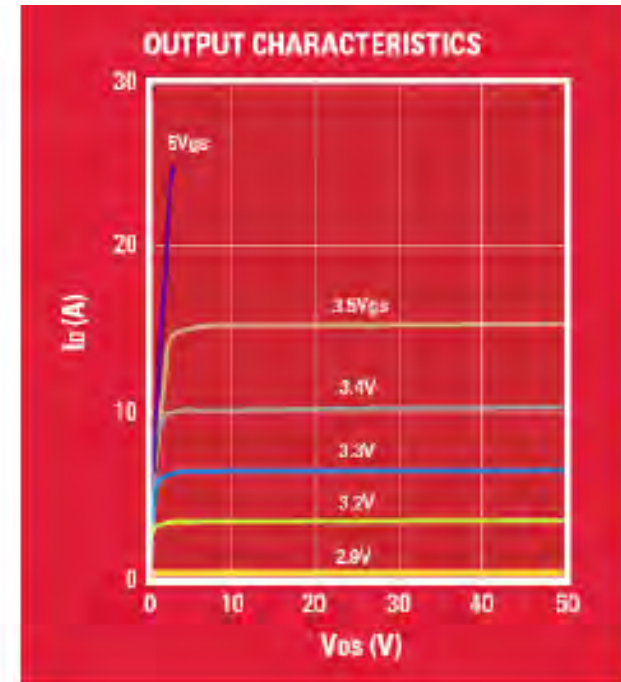
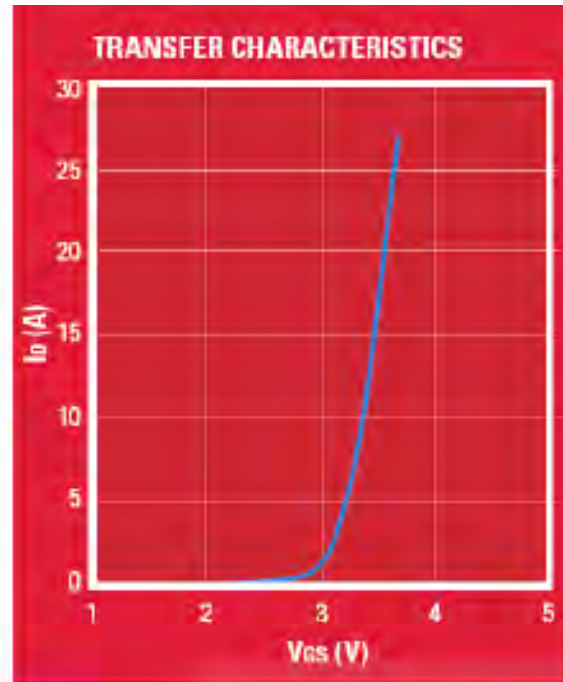




What about “Normally Off” devices?



Cascode Switch

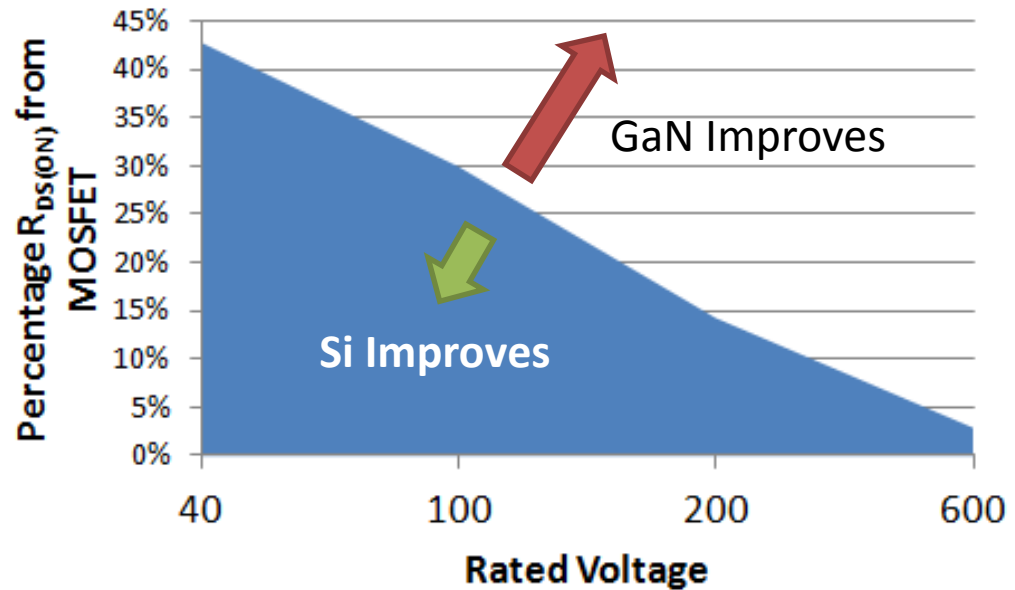
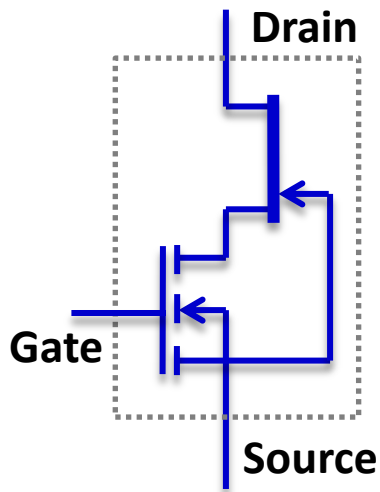


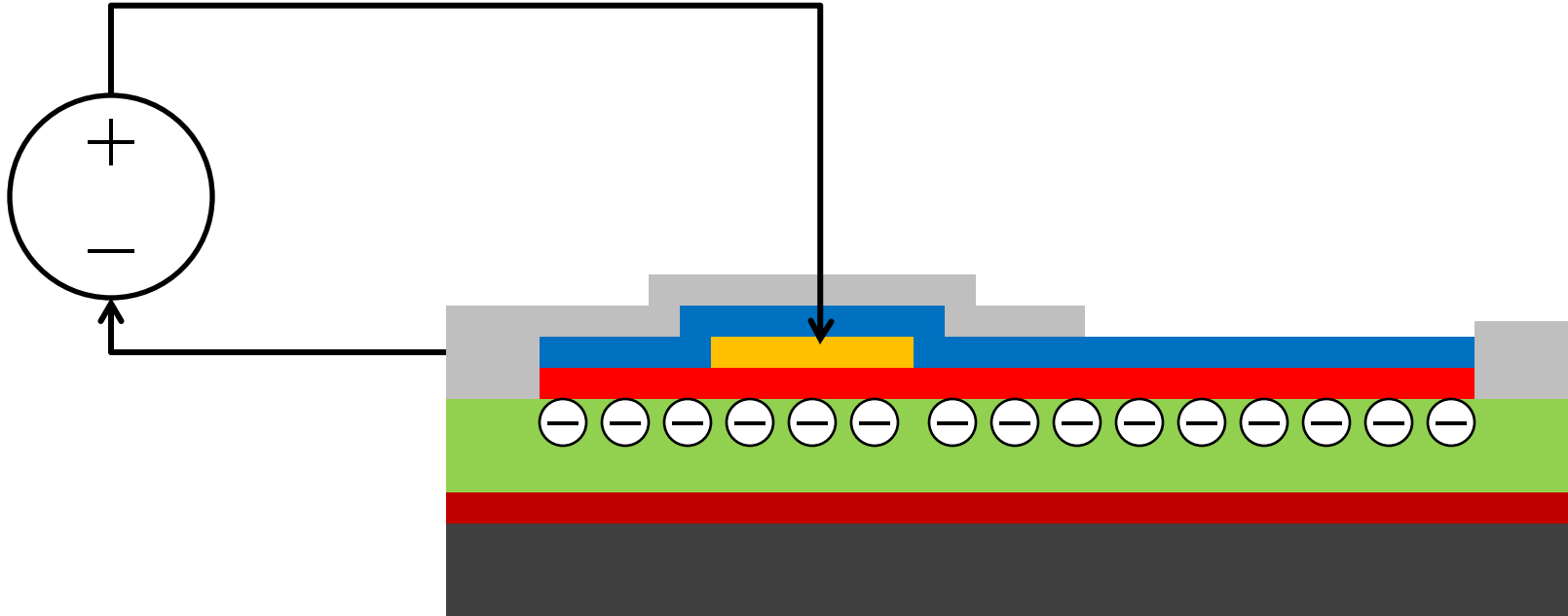
Highlights:

- Normally Off operation
- Gate drive compatible with existing Silicon solutions: +/-10V, +/- 15V , etc.
- V_{gs(th)} can be tailored with Si FET: high enough to avoid C*dV/dt induced turn on
- Anti-parallel diode function included: lower reverse recovery losses than Si switches

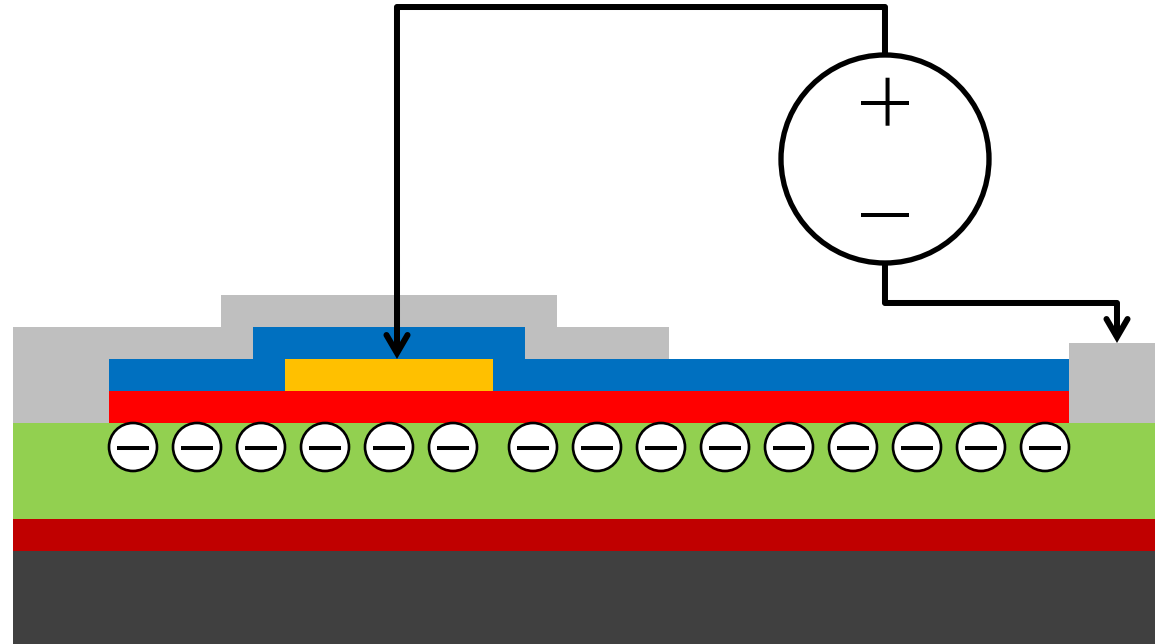
Reference: “The Status of GaN Power Device Development at International Rectifier,” PCIM 2012

Cascode devices combine a depletion mode GaN transistor with a low voltage enhancement mode MOSFET

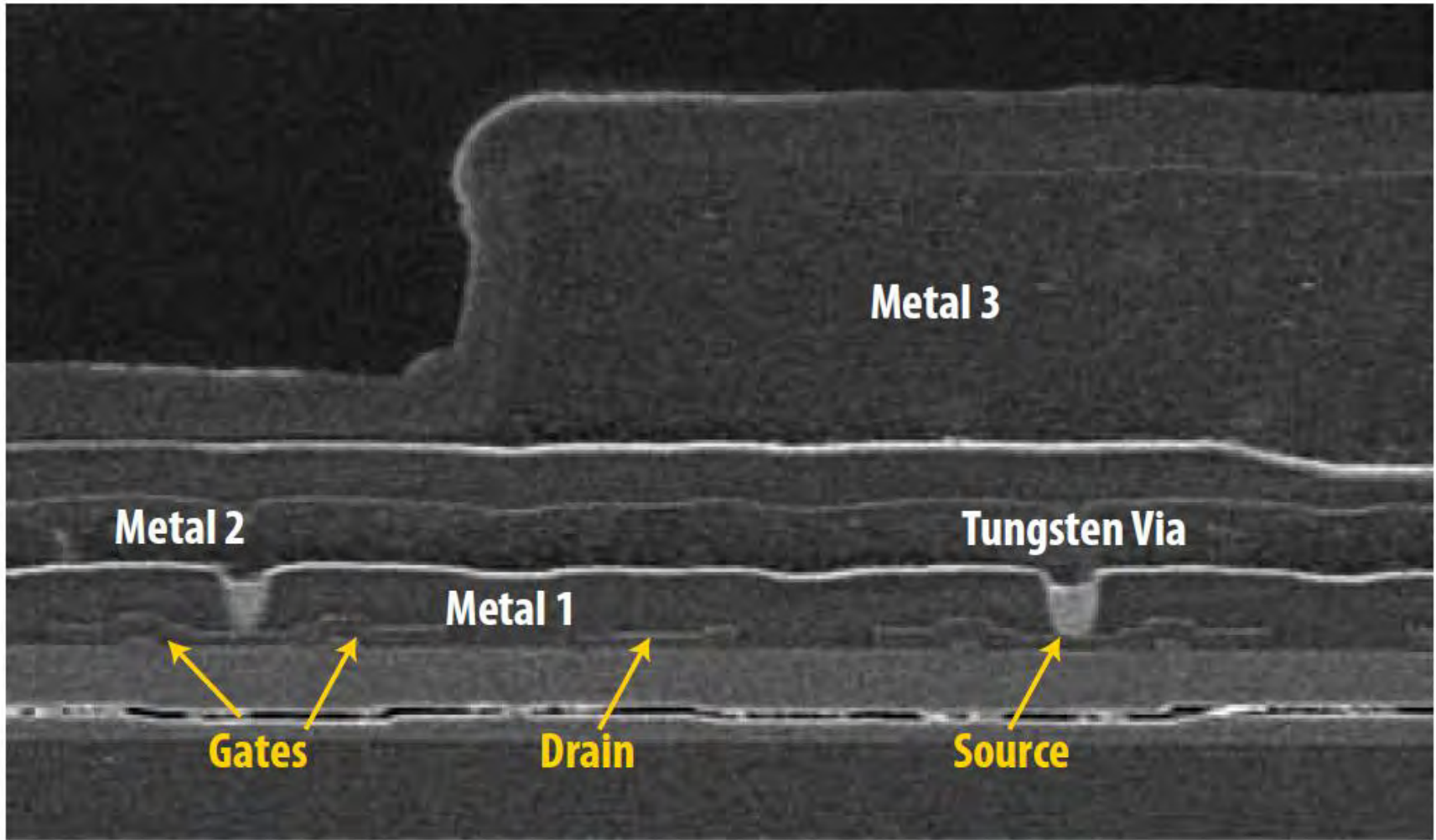




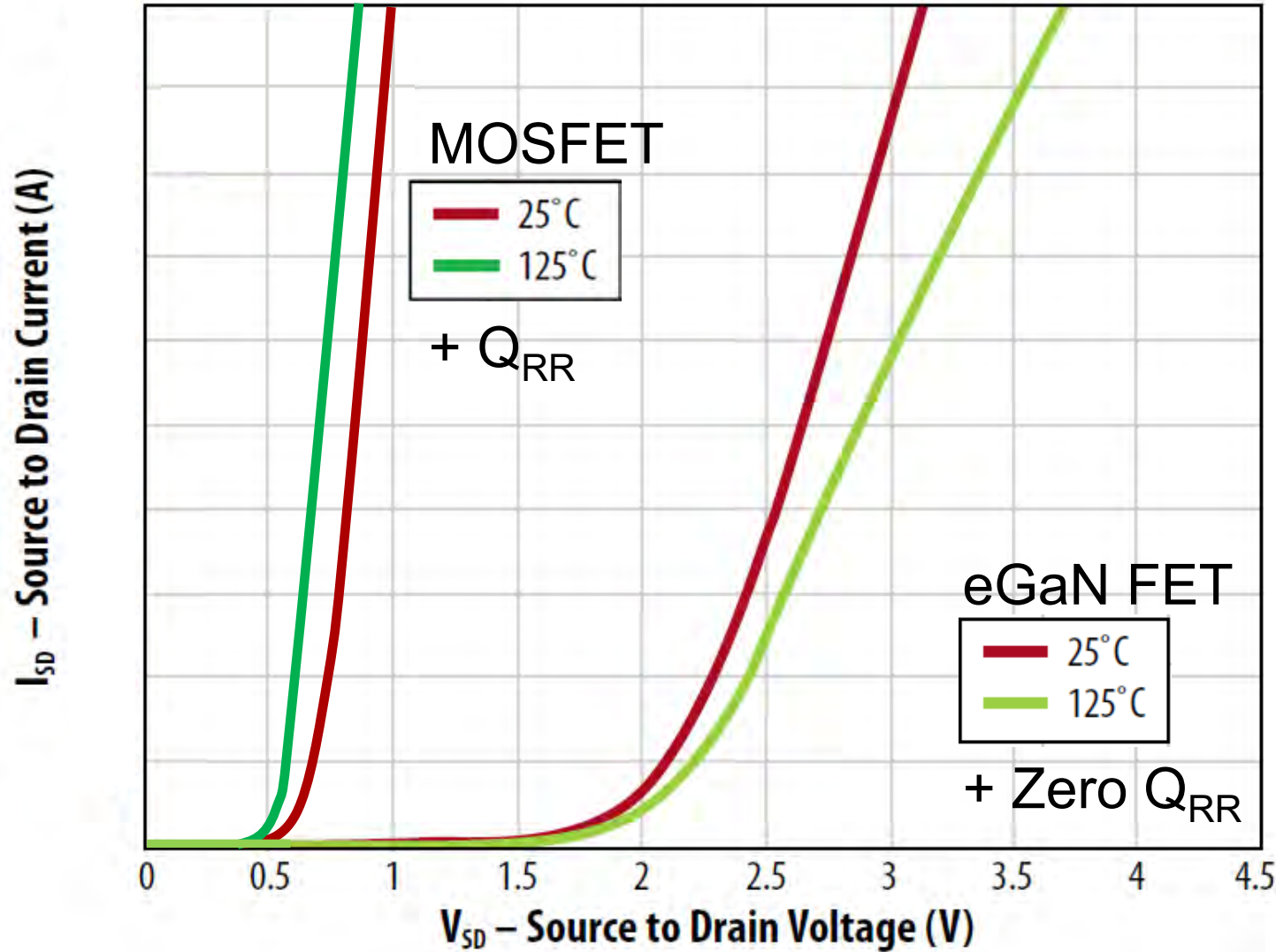
A positive voltage from Gate-To-Source establishes an electron gas under the gate

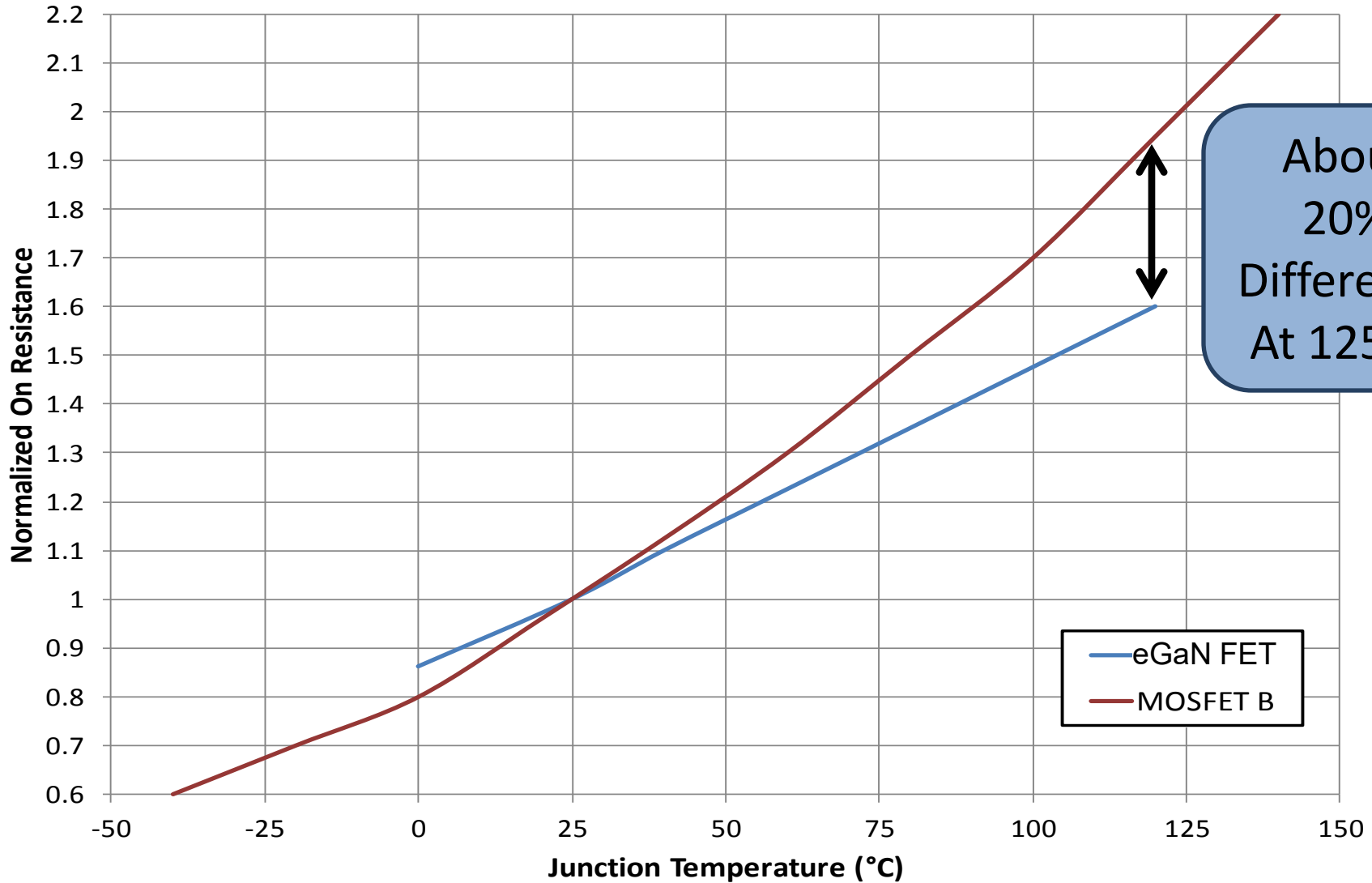


A positive voltage from Gate-To-Drain also establishes an electron gas under the gate



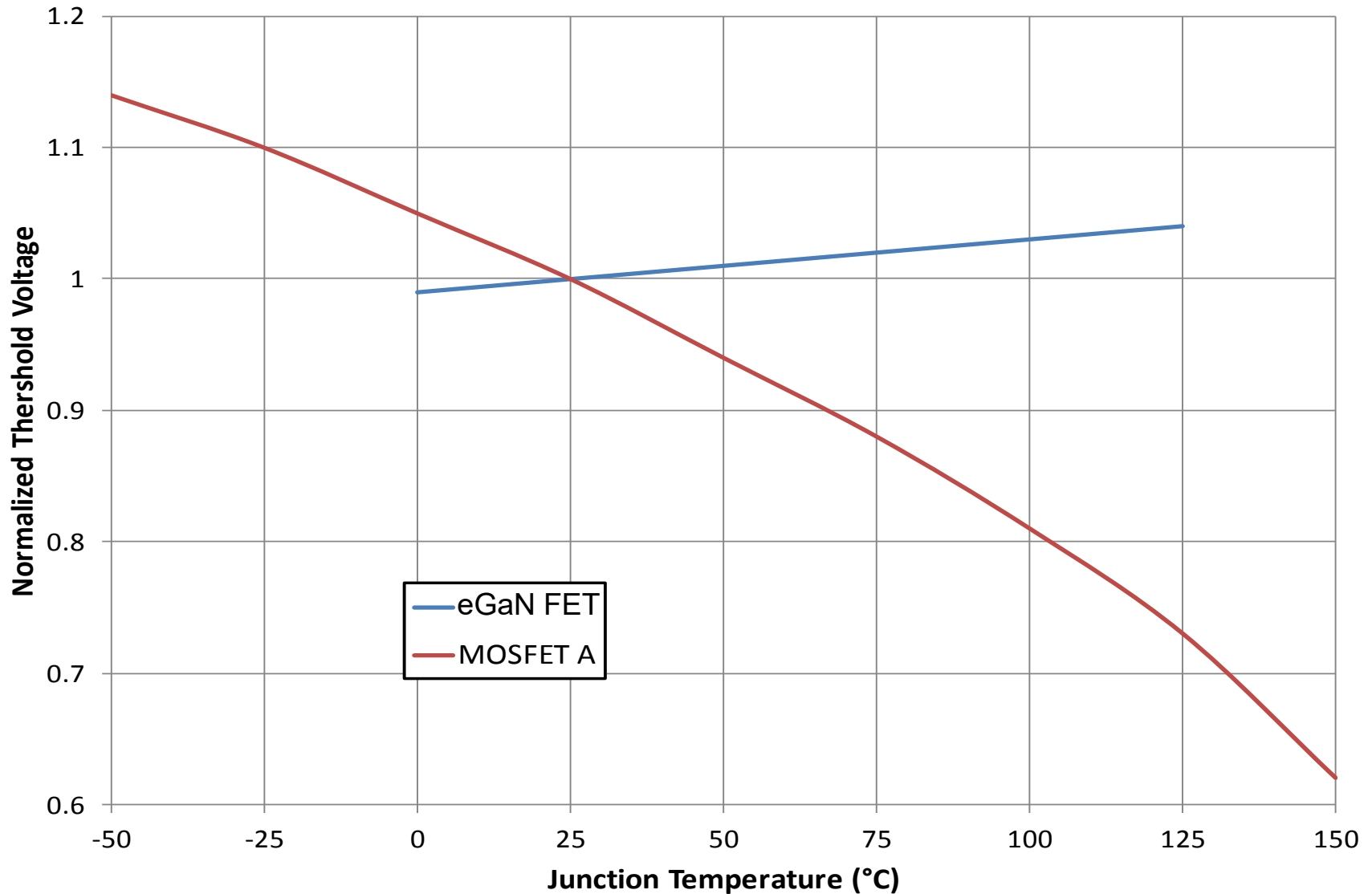
Electrical Characteristics



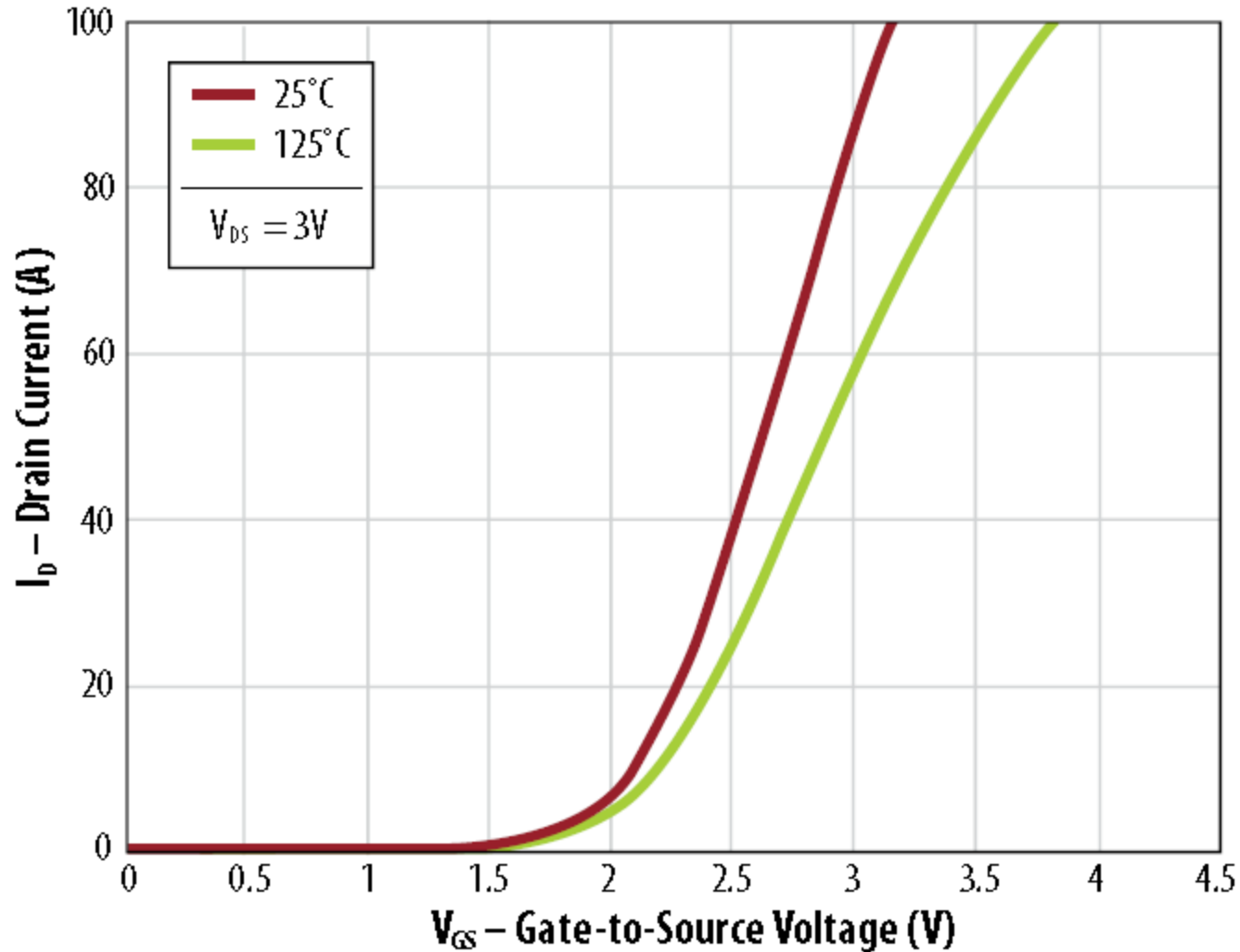


About
20%
Difference
At 125 °C

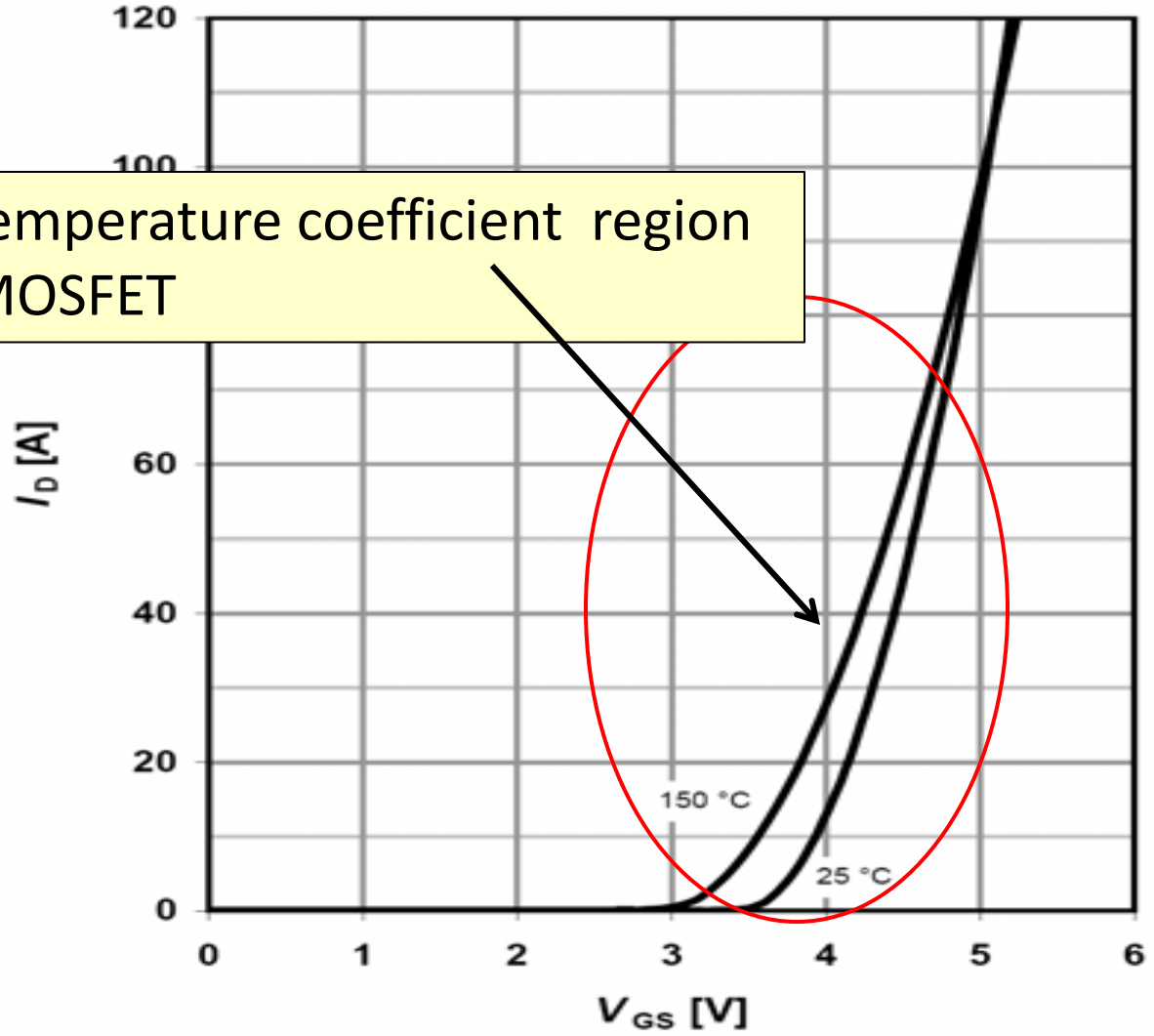
— eGaN FET
— MOSFET B



EPC2001

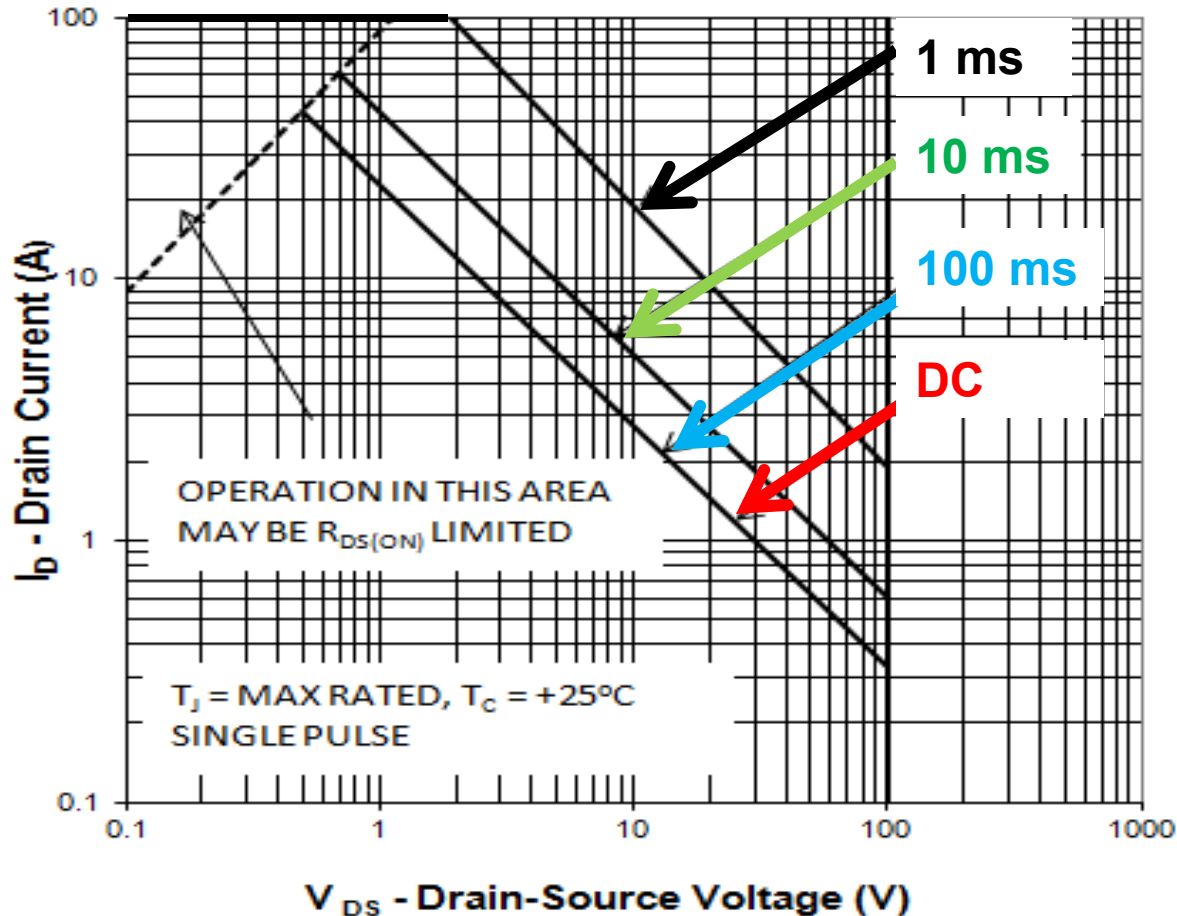


Negative temperature coefficient region of silicon MOSFET

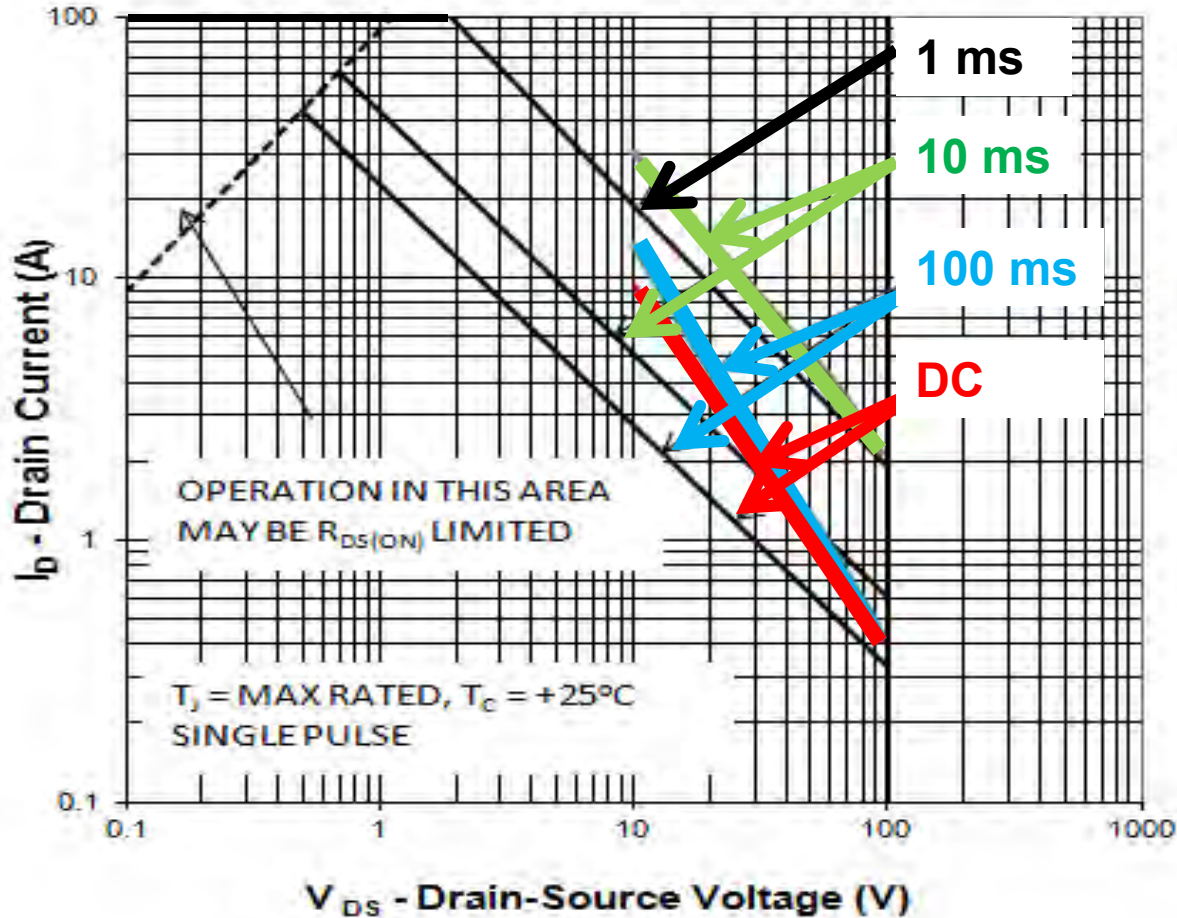


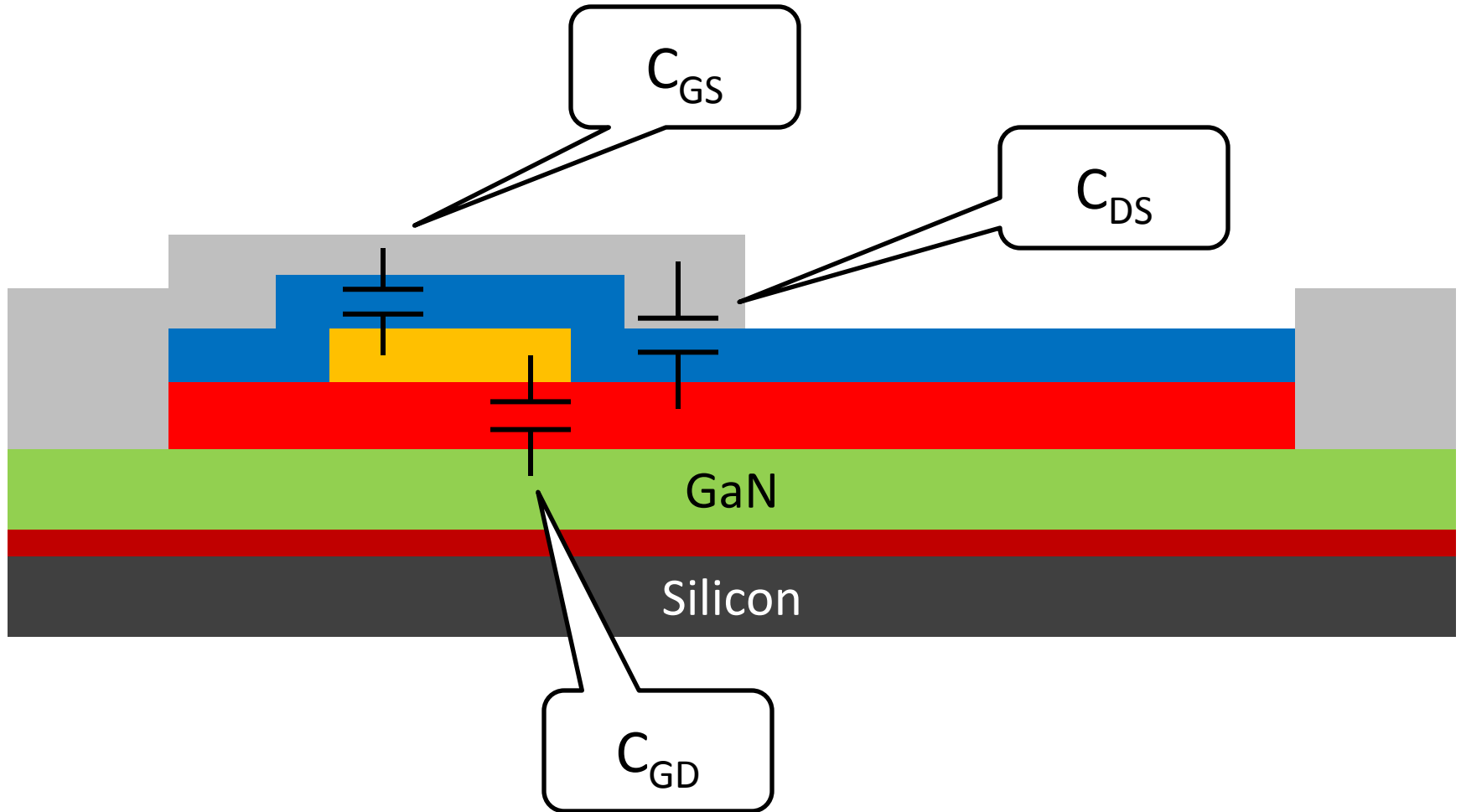
Source: www.infineon.com

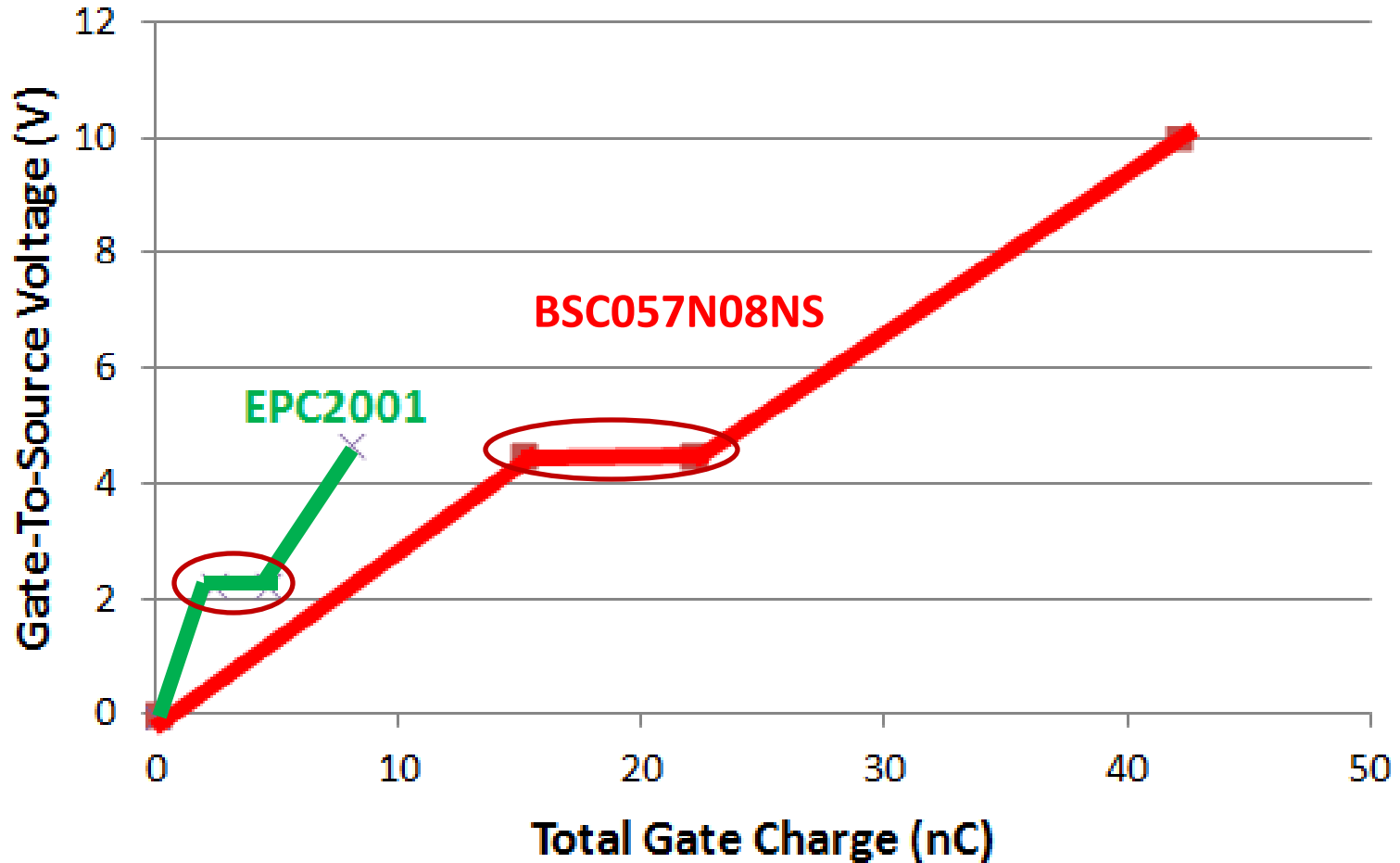
EPC2001: MAXIMUM FORWARD BIAS SAFE OPERATING AREA



EPC2001: MAXIMUM FORWARD BIAS SAFE OPERATING AREA



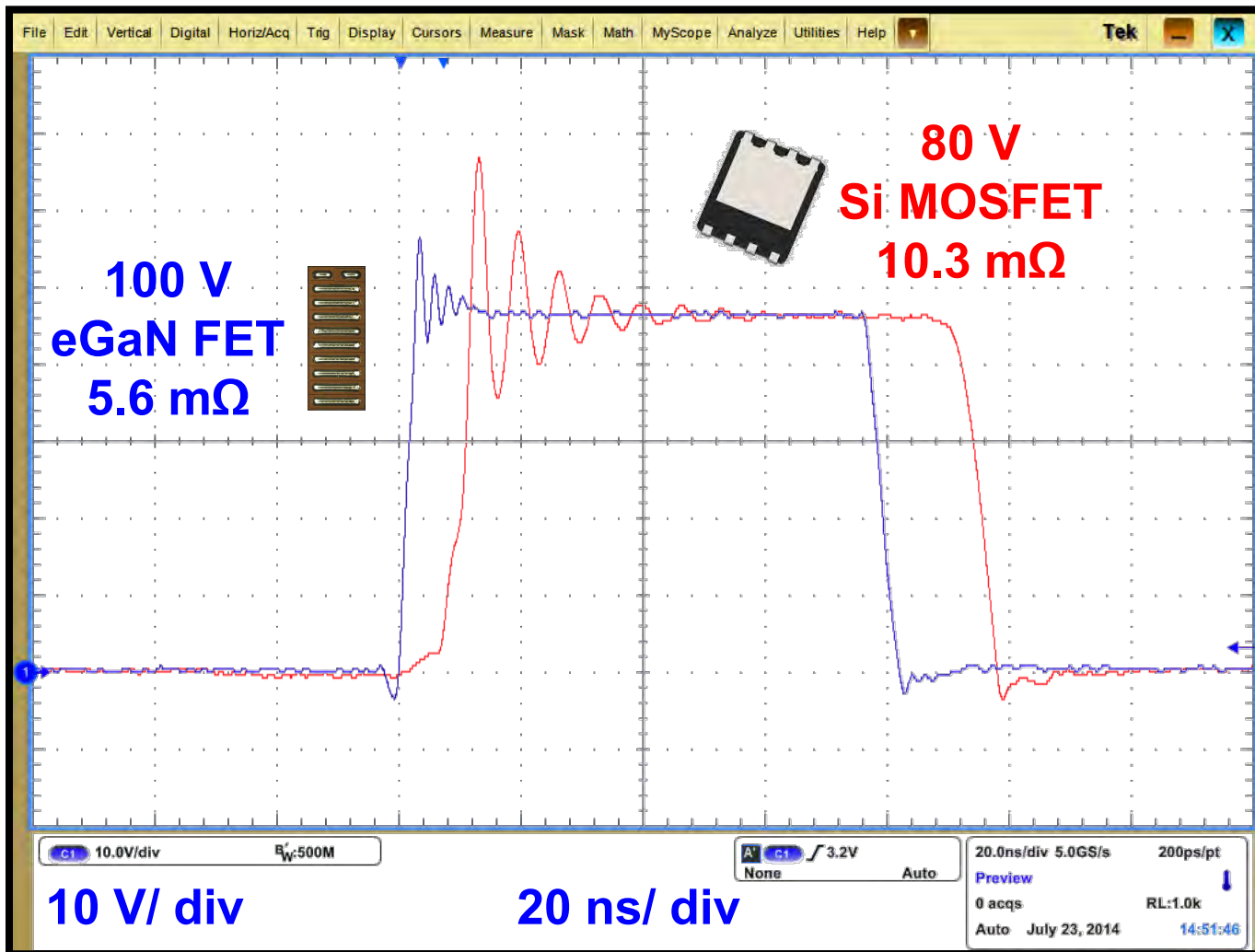




EPC2001 = 100 V, 5.6 mΩ typ.

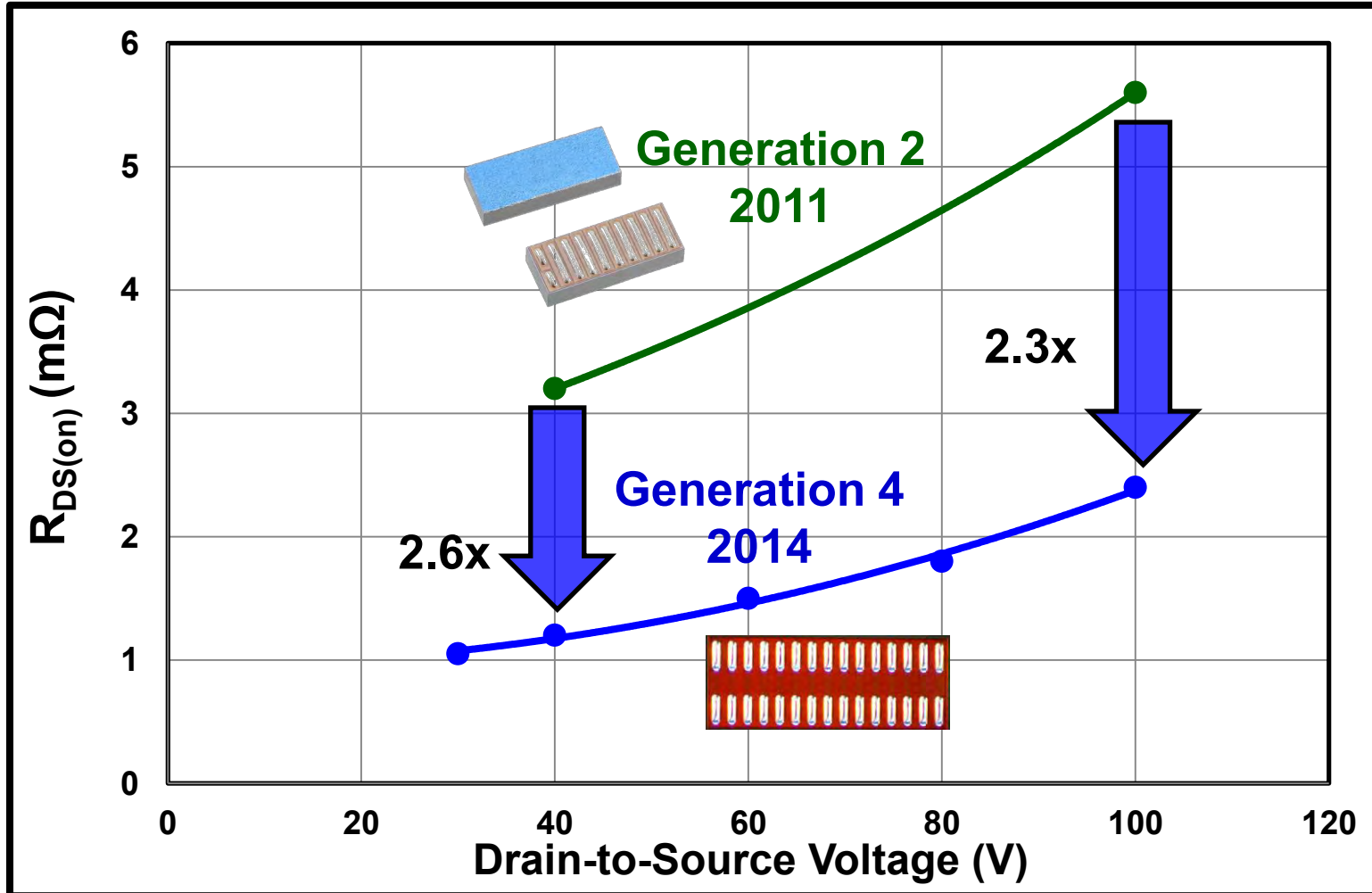
BSC057N08 = 80 V, 4.7 mΩ typ.

Switching Comparison



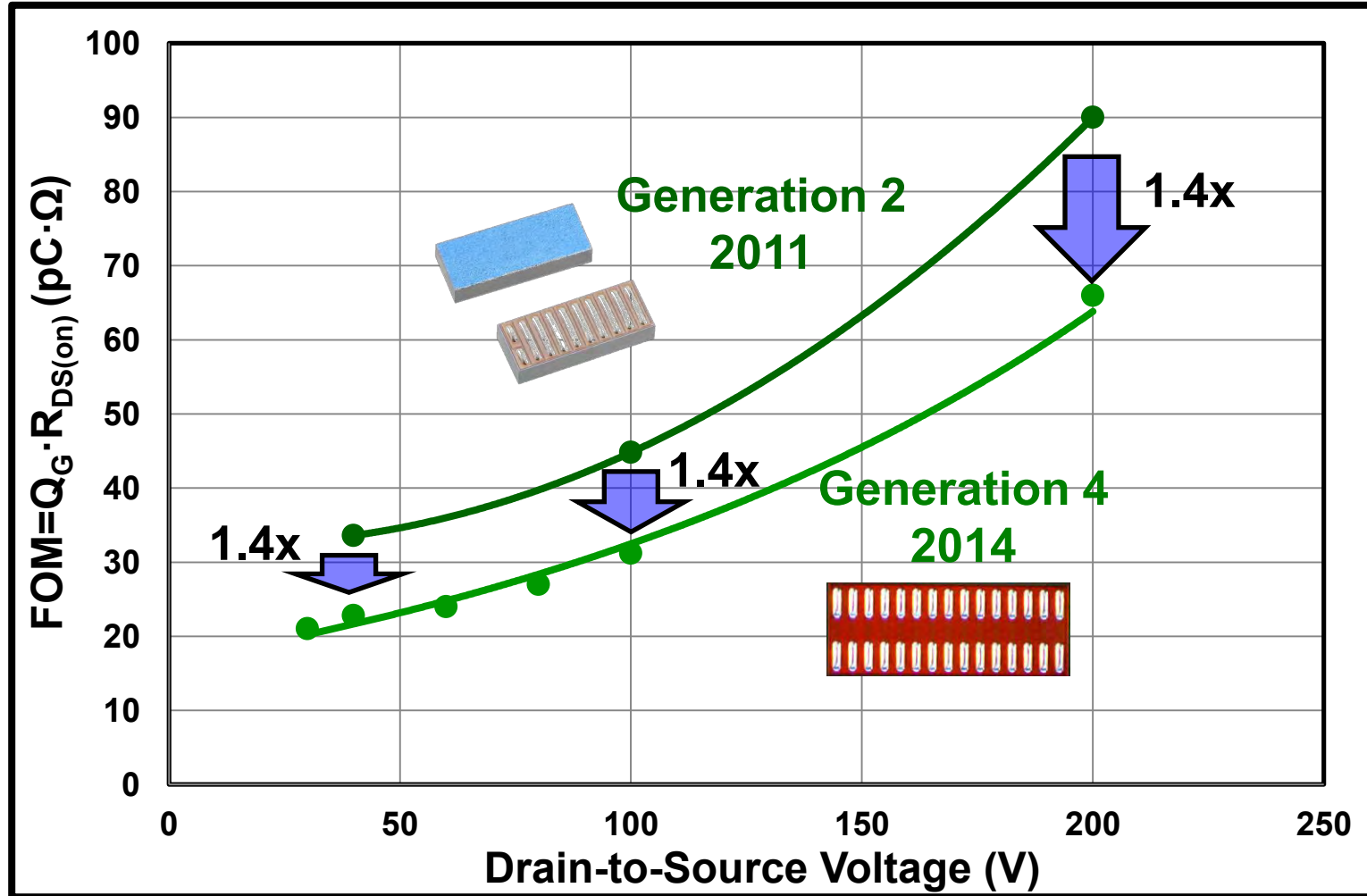
$V_{IN}=48\text{ V}$ $V_{OUT}=1\text{ V}$ $I_{OUT}=10\text{ A}$ $f_{sw}=300\text{ kHz}$ $L=10\text{ }\mu\text{H}$ eGaN FET T/SR: 100 V EPC2001
MOSFET T/SR: 80 V BSZ123N08NS3G

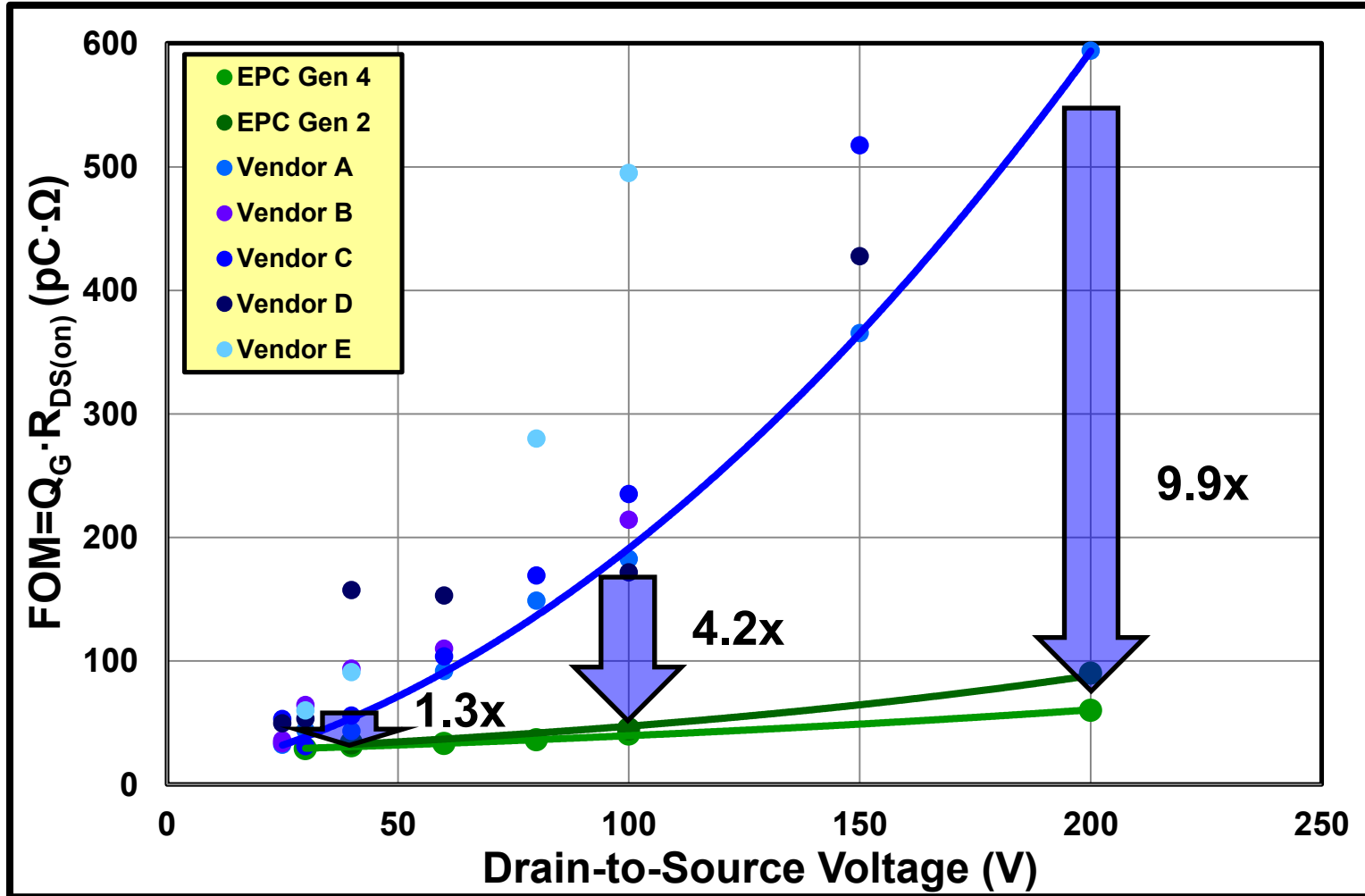
GaN Improvements

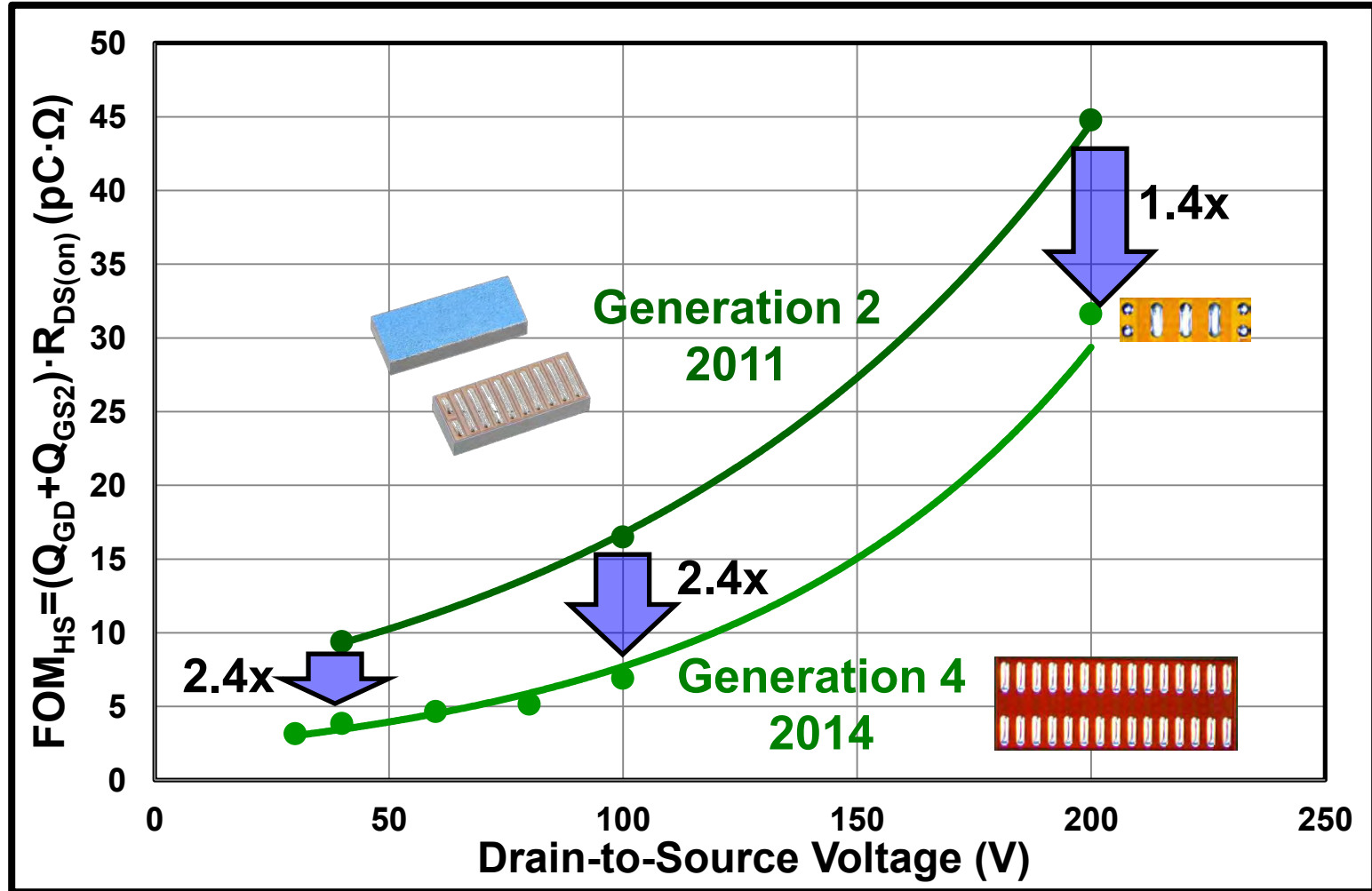


$V_{GS} = 5\text{ V}$

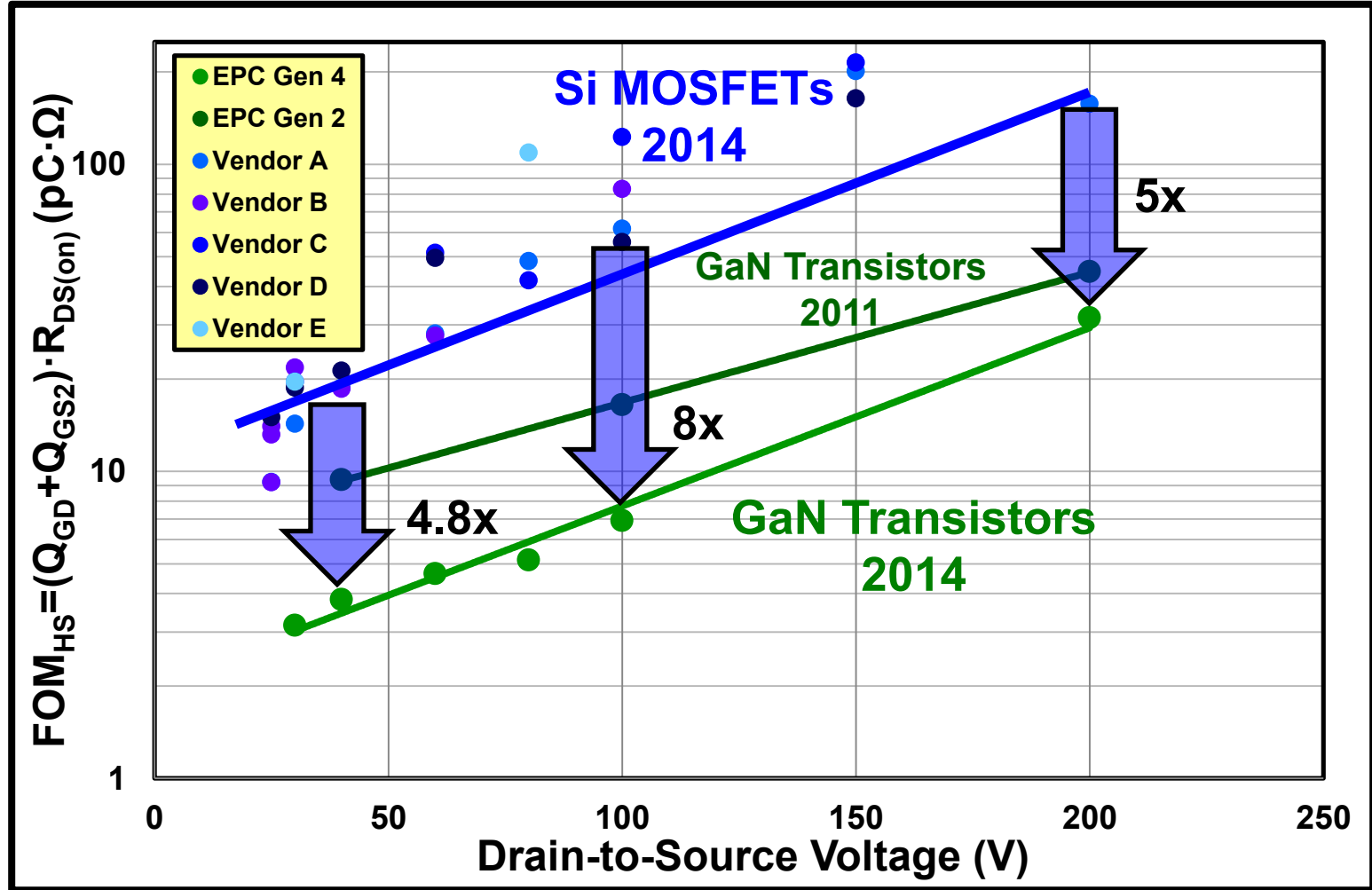
Gate Charge FOM



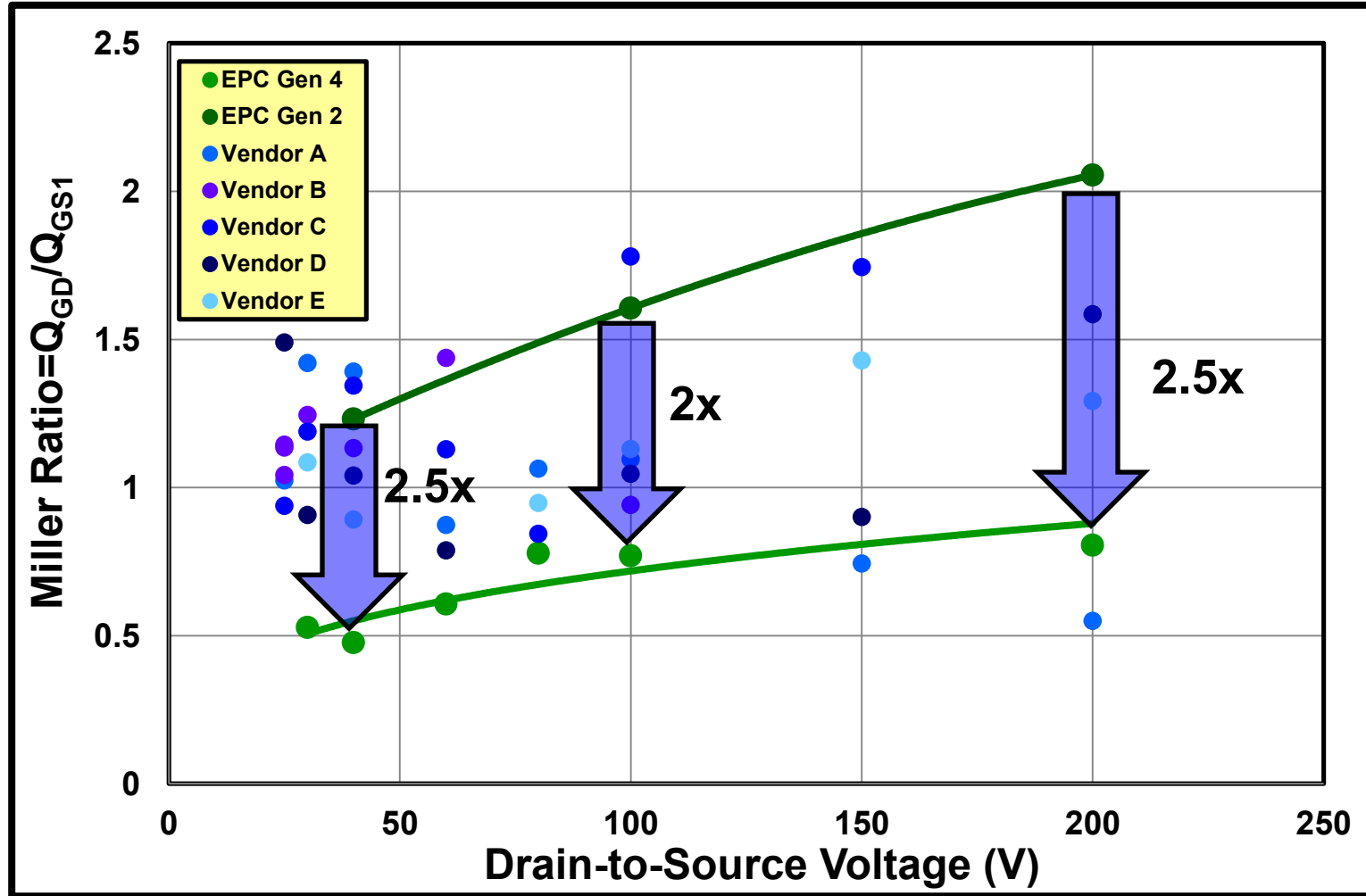




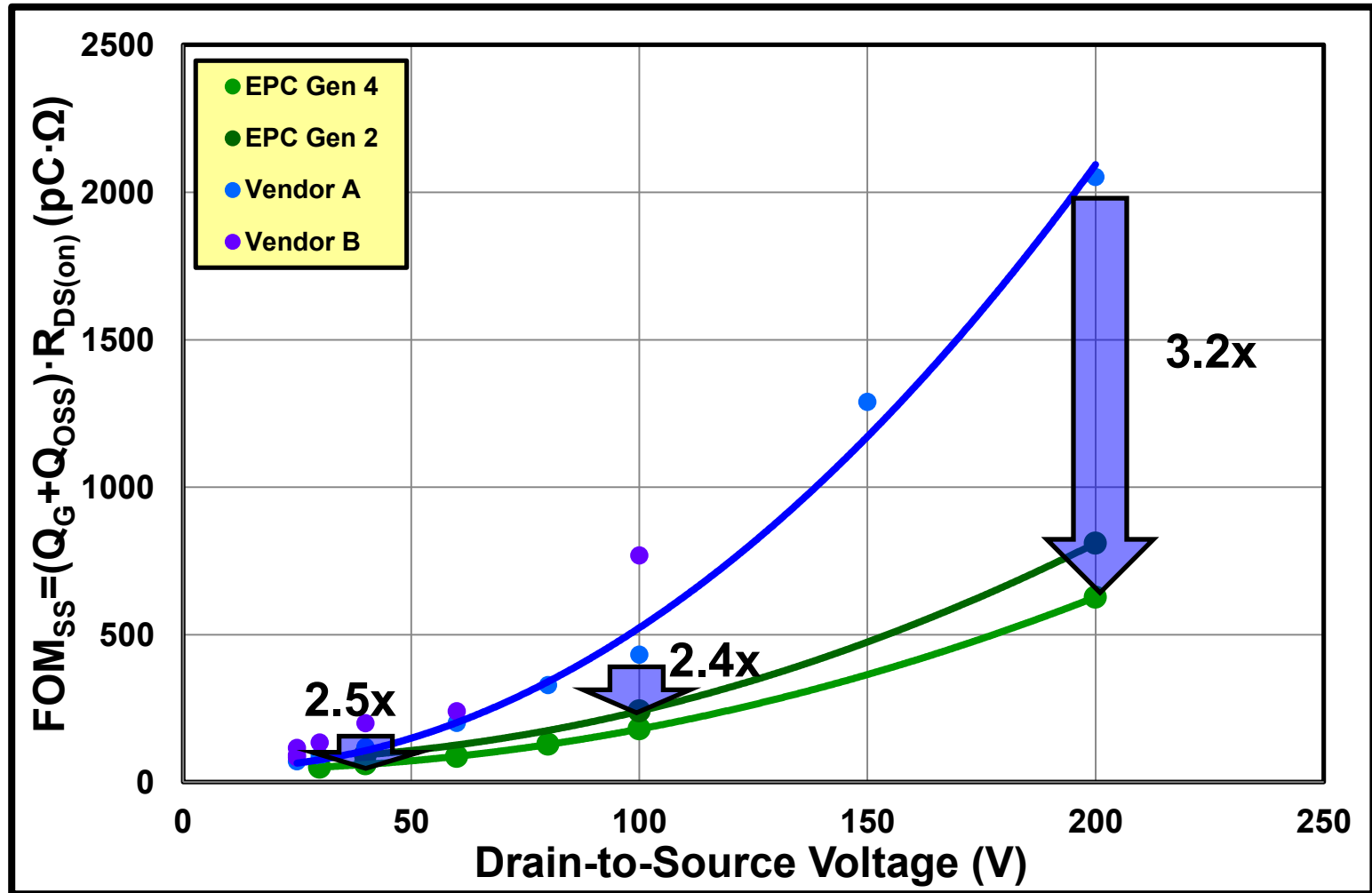
$$V_{DS} = 0.5 \cdot V_{DSS}, I_{DS} = 20 \text{ A}$$



$$V_{DS} = 0.5 \cdot V_{DSS}, I_{DS} = 20 \text{ A}$$



$V_{DS} = 0.5 \cdot V_{DSS}, I_{DS} = 20 \text{ A}$



$$V_{DS} = 0.5 \cdot V_{DSS}$$

Like A MOSFET

- I^2R Conduction Loss
- Capacitive Switching Losses
- Gate Drive Losses
- $V \times I$ Switching Loss



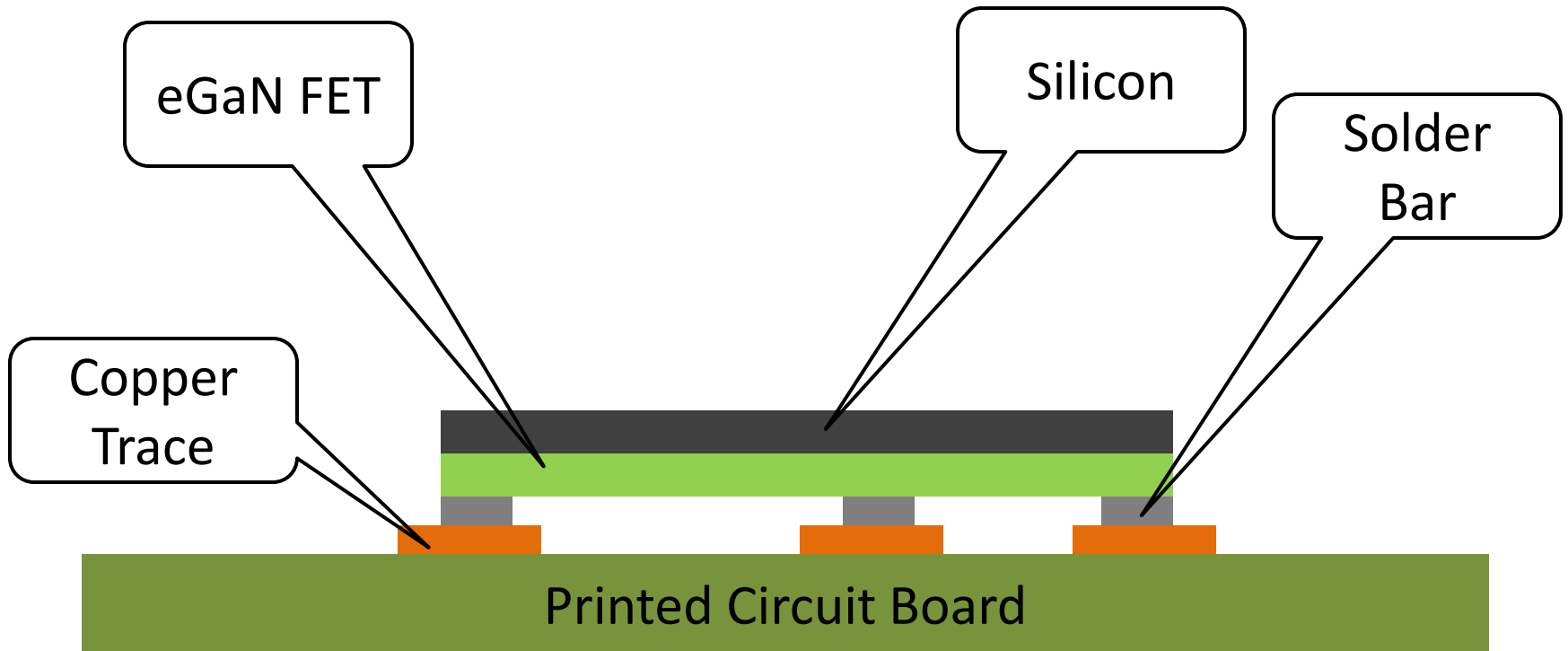
Not Like A MOSFET

- High Reverse Conduction Loss
- No Body Diode Reverse Recovery Loss



Can be much, much better than
comparable silicon MOSFET

- Low parasitic resistance
- Low parasitic inductance
- Low thermal resistance
- Small size
- Low cost



**Absolute minimum
lead resistance and inductance!**

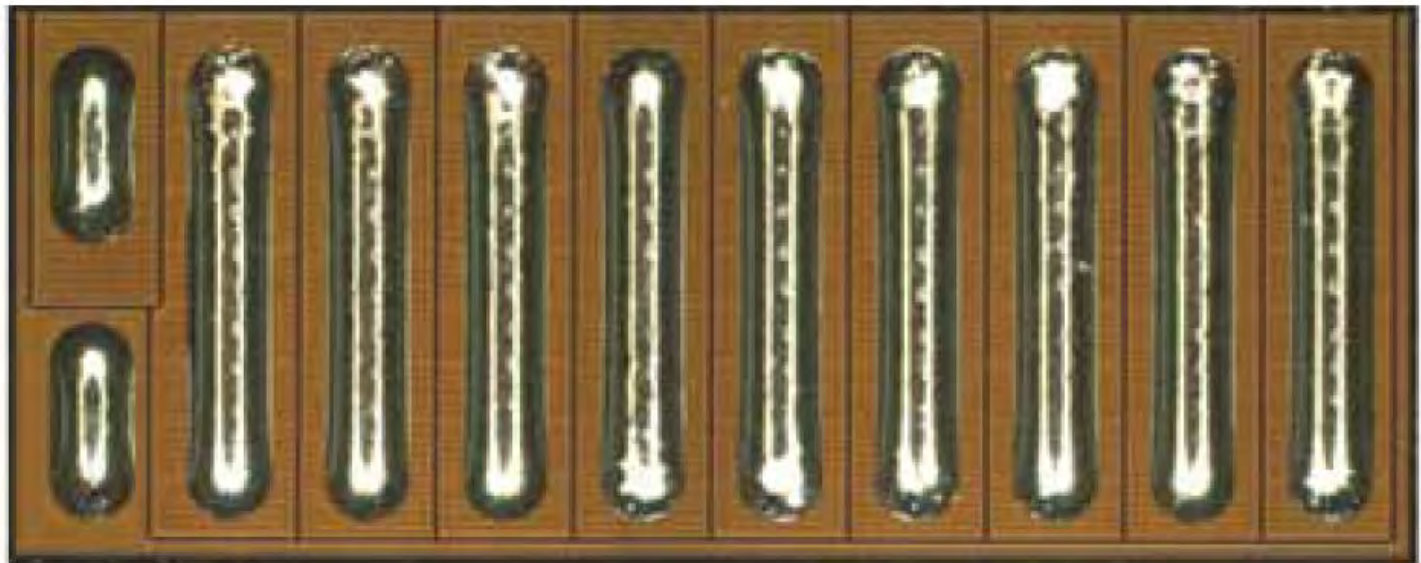
Drain Contacts

Interleaving to reduce layout inductance



Substrate

Gate



Source Contacts

eGaN FET



5.76 mm²

D-PAK



65.3 mm²

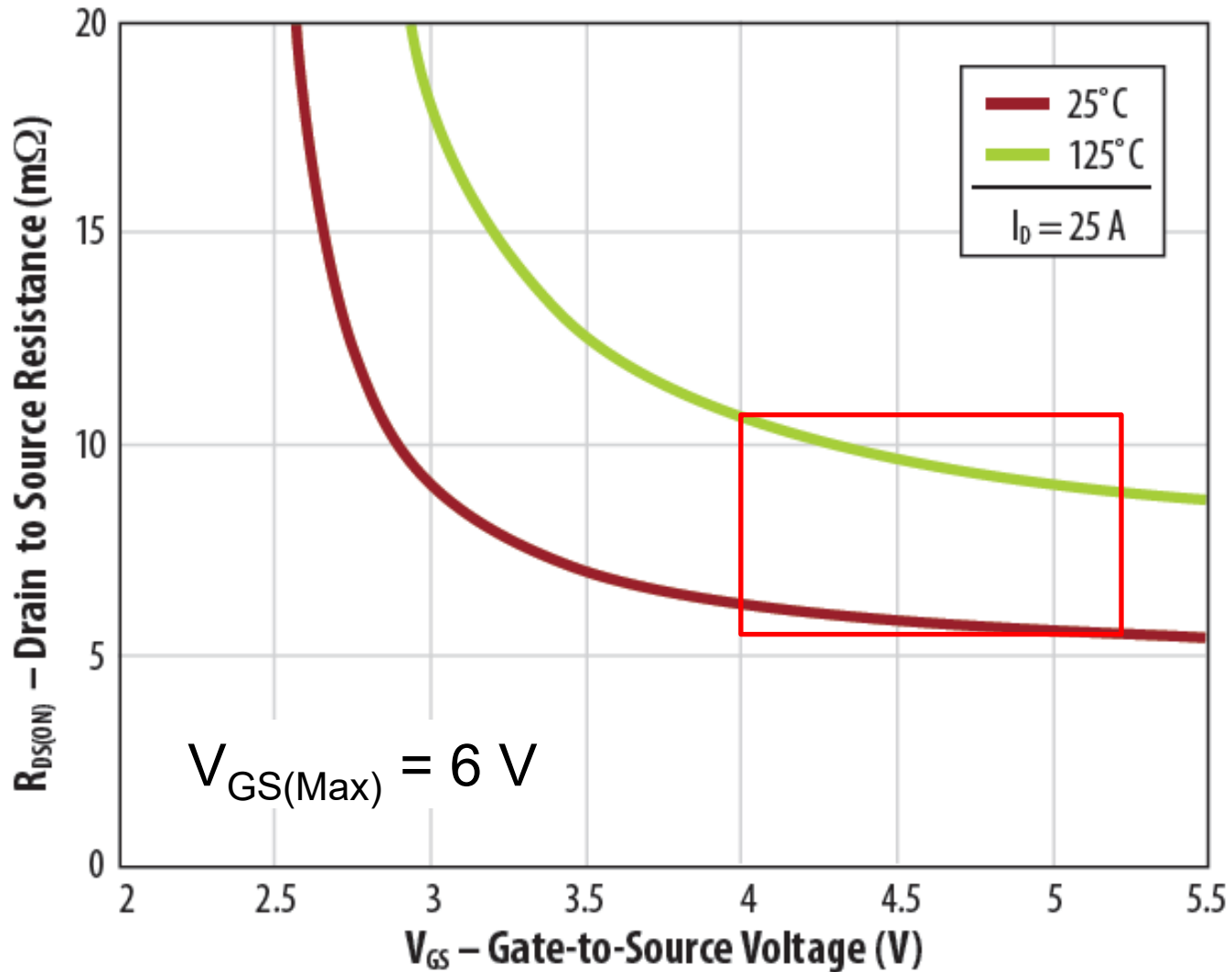
Drawn To Scale

Design Basics

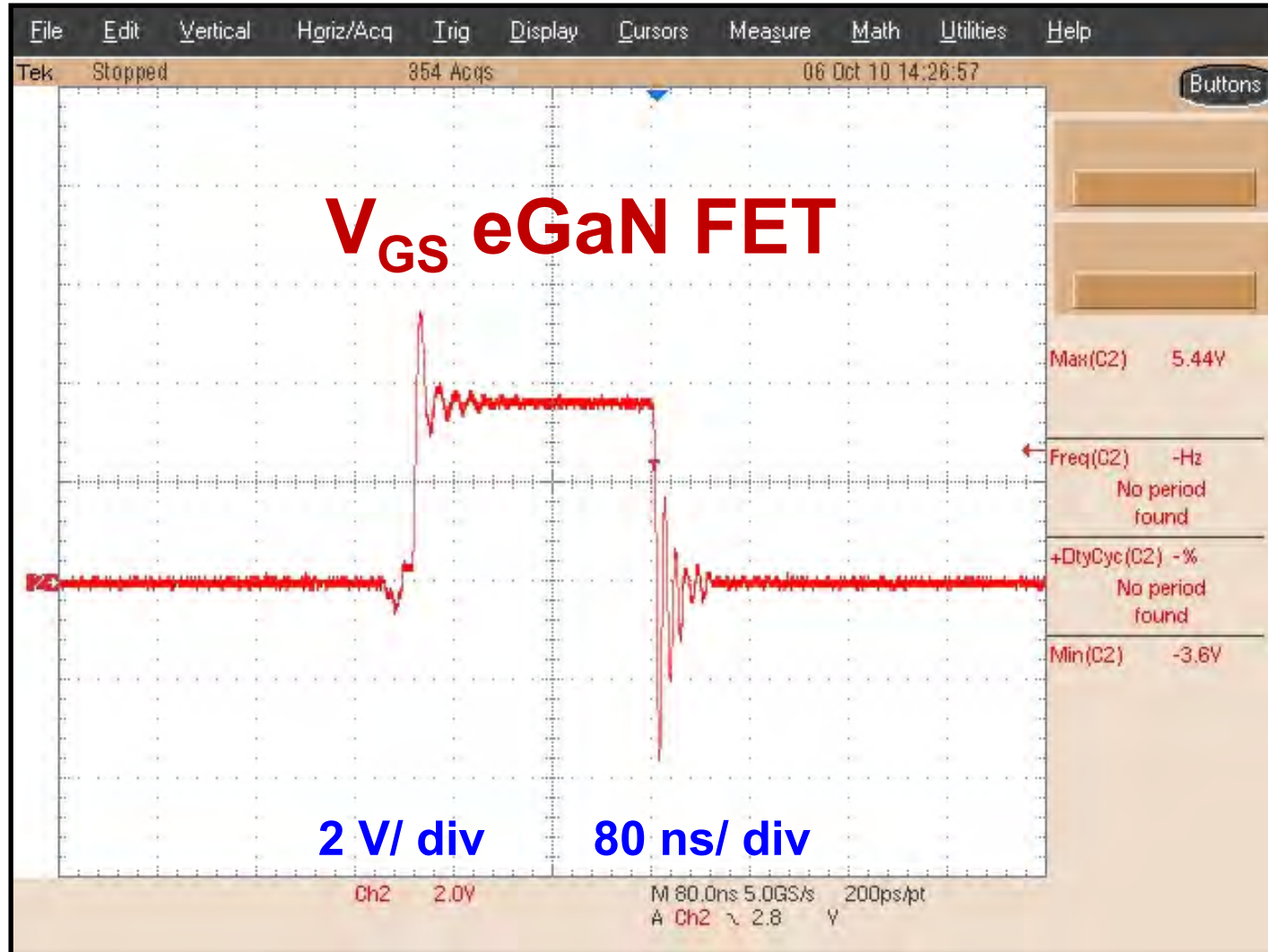
- Requirements for:
 - Gate Driver
 - Dead-time
 - Layout
 - Paralleling
 - Thermal
 - Measurement

Gate Drive

Low $V_{GS(on)}$ Overhead

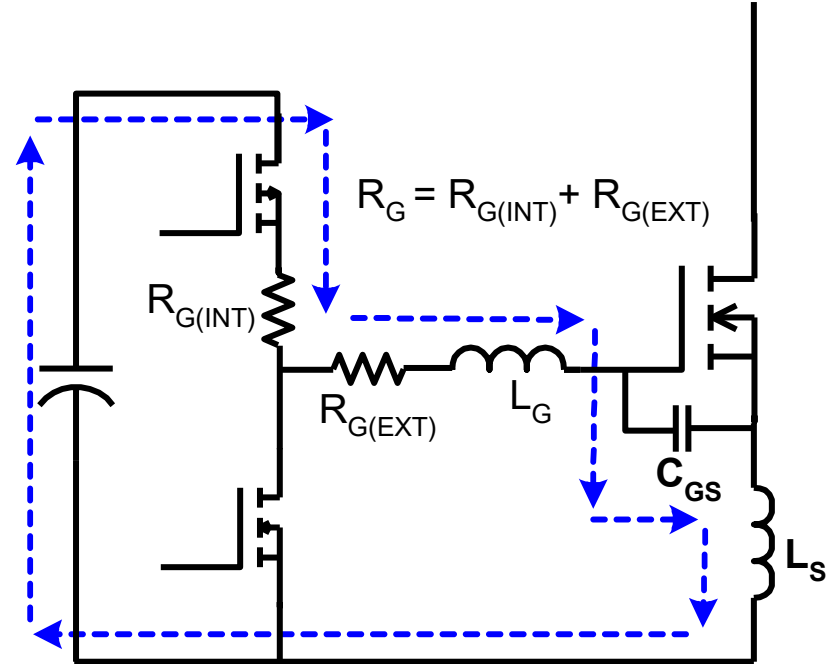


Minimizing Overshoot



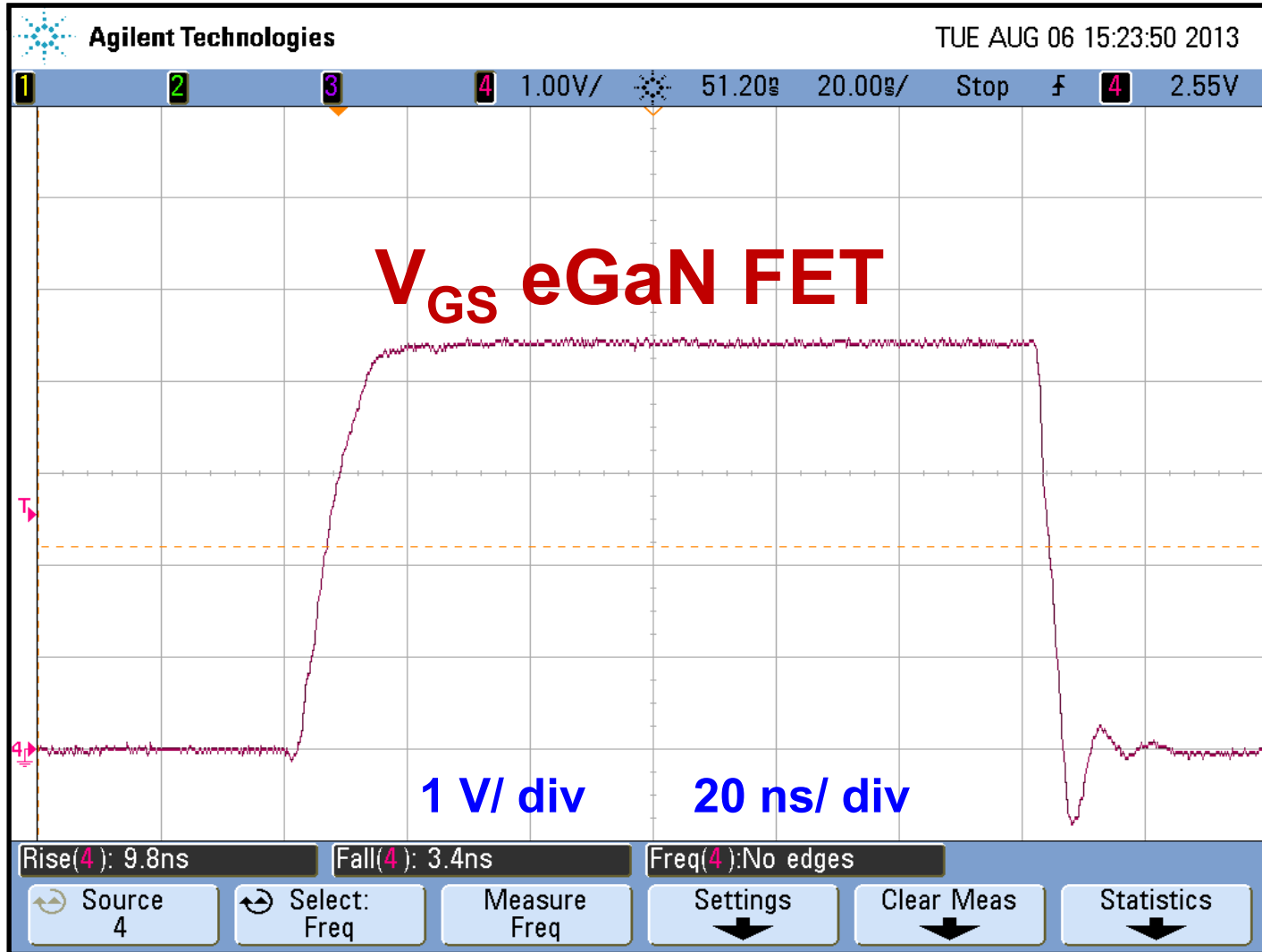
To avoid overshoot:

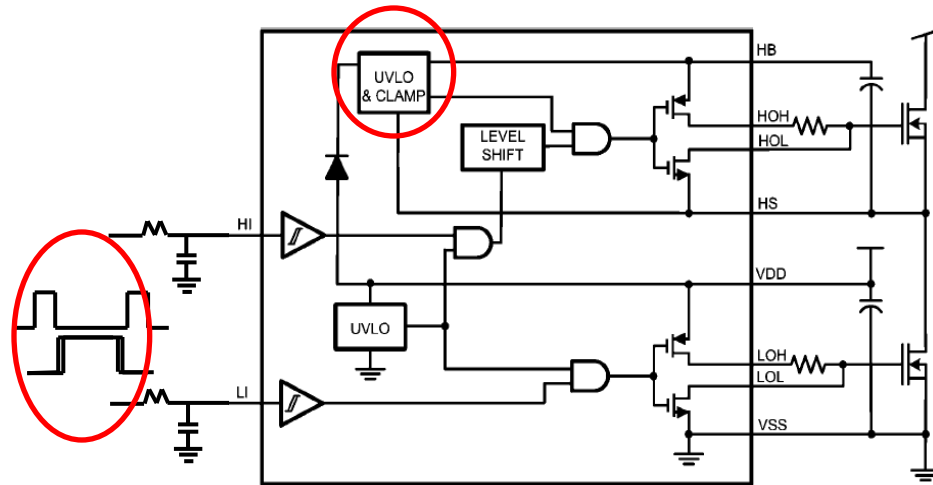
$$R_G \geq \sqrt{\frac{4(L_G + L_S)}{C_{GS}}}$$



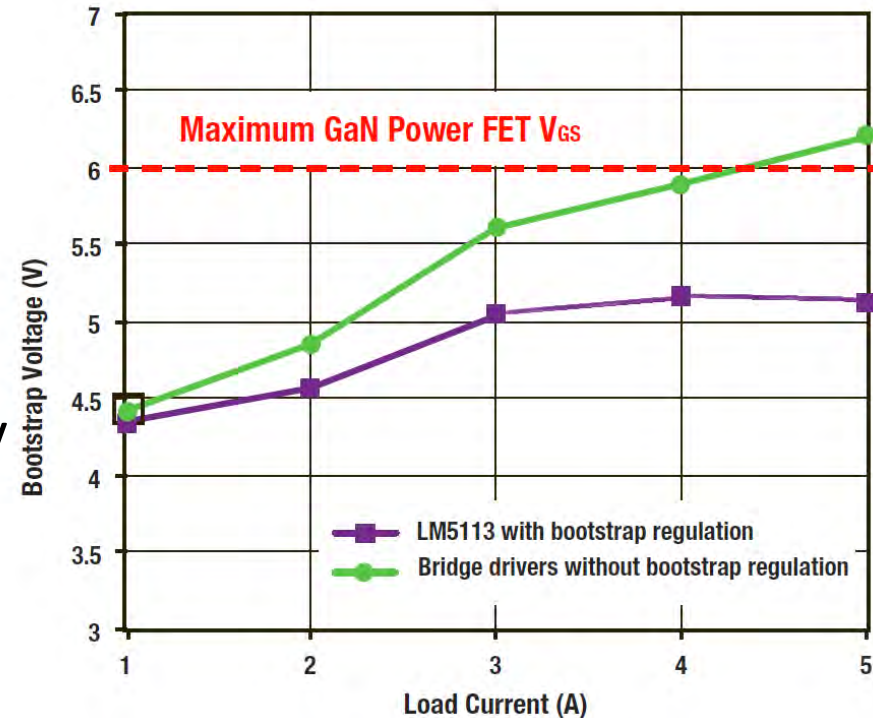
- Minimize gate loop inductance
- Separate source and sink transistors allowing for separate drive paths

Minimizing Overshoot



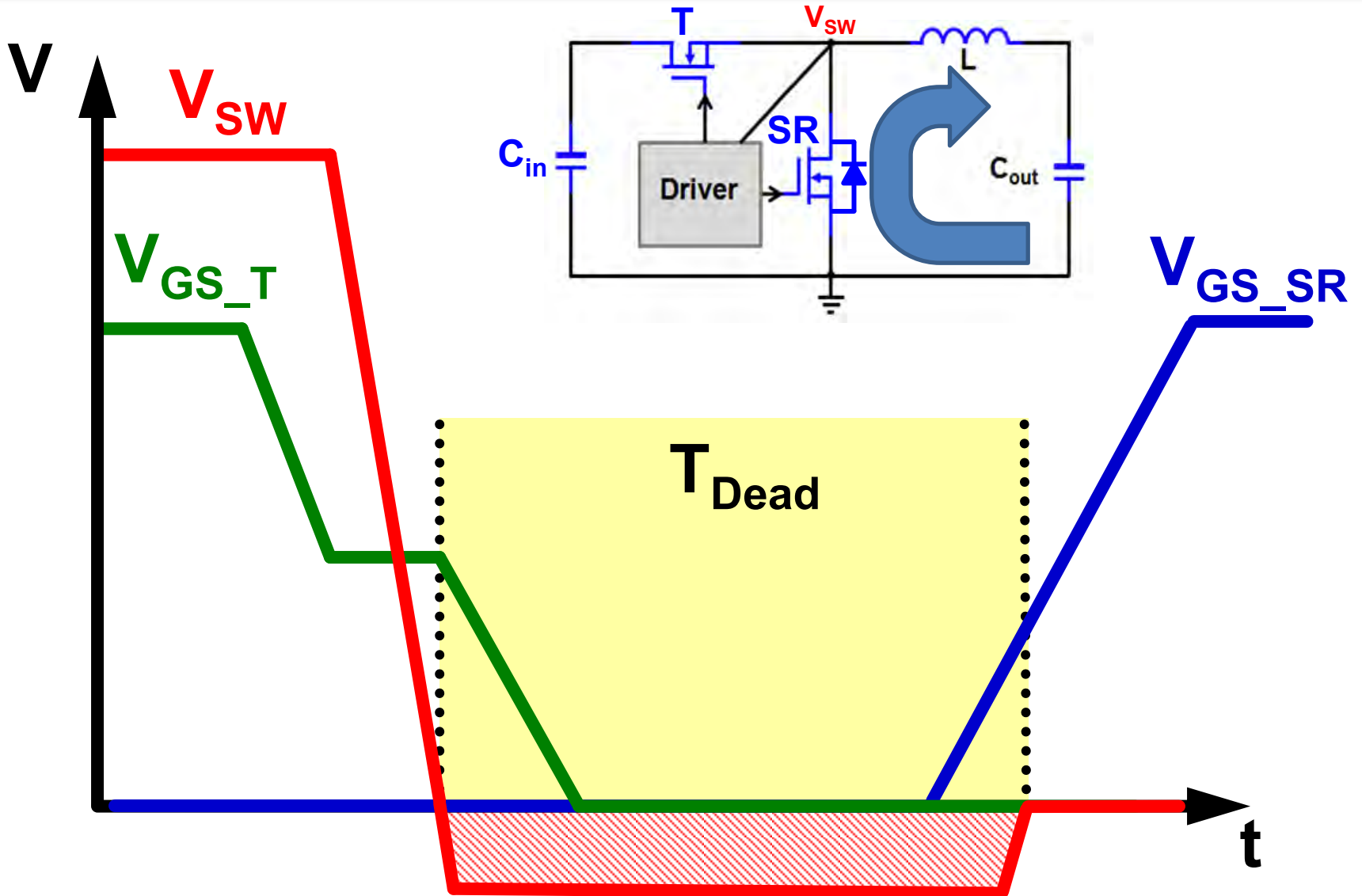


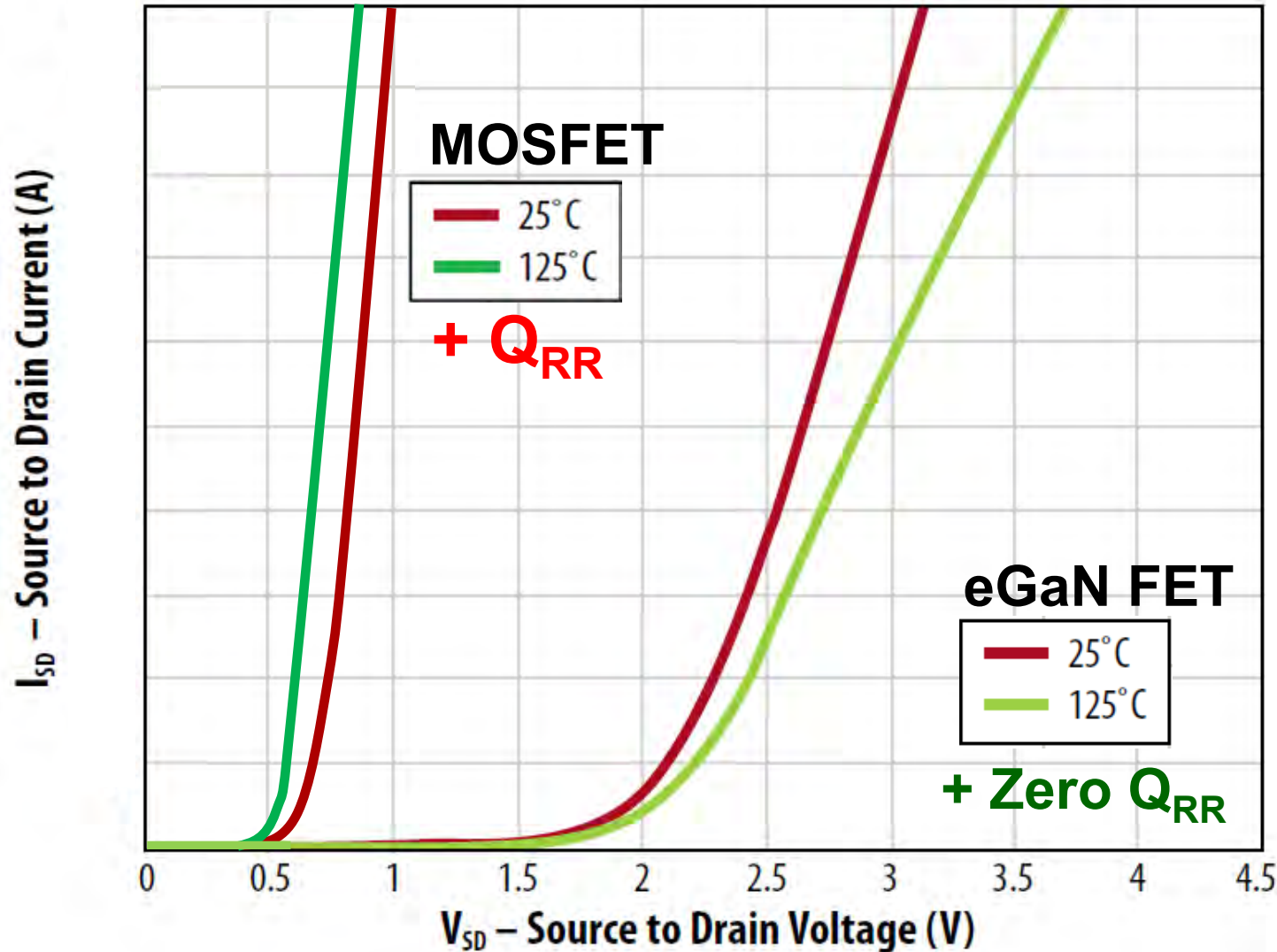
- Bootstrap clamp limits (HS) supply
- Separate inputs allow accurate, dead-time management
- Optimized drive impedance

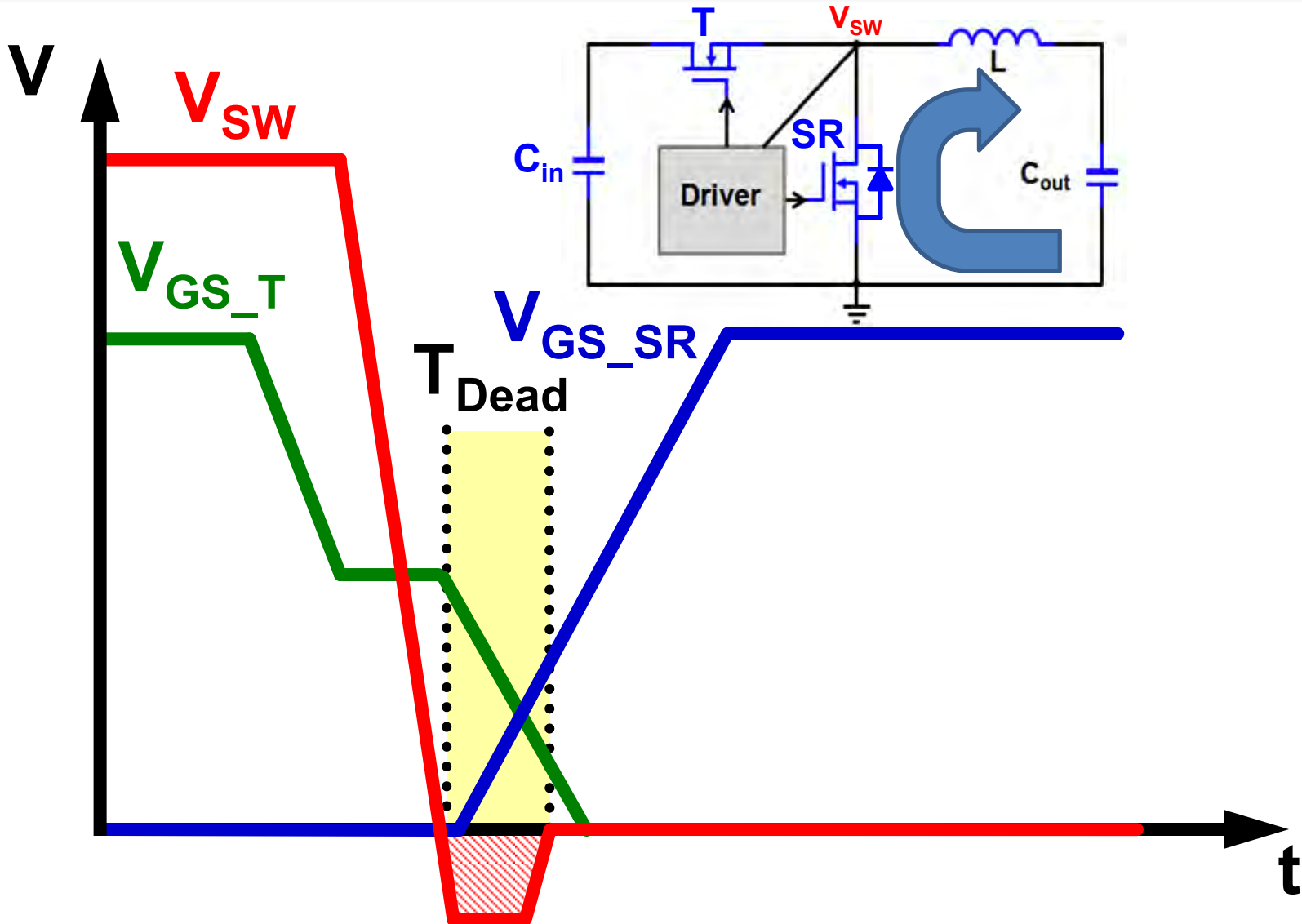


Reference: Texas Instruments, "Gate Drivers for Enhancement Mode GaN Power FETs 100 V Half-Bridge and Low-Side Drivers Enable Greater Efficiency, Power Density, and Simplicity," SNVB001

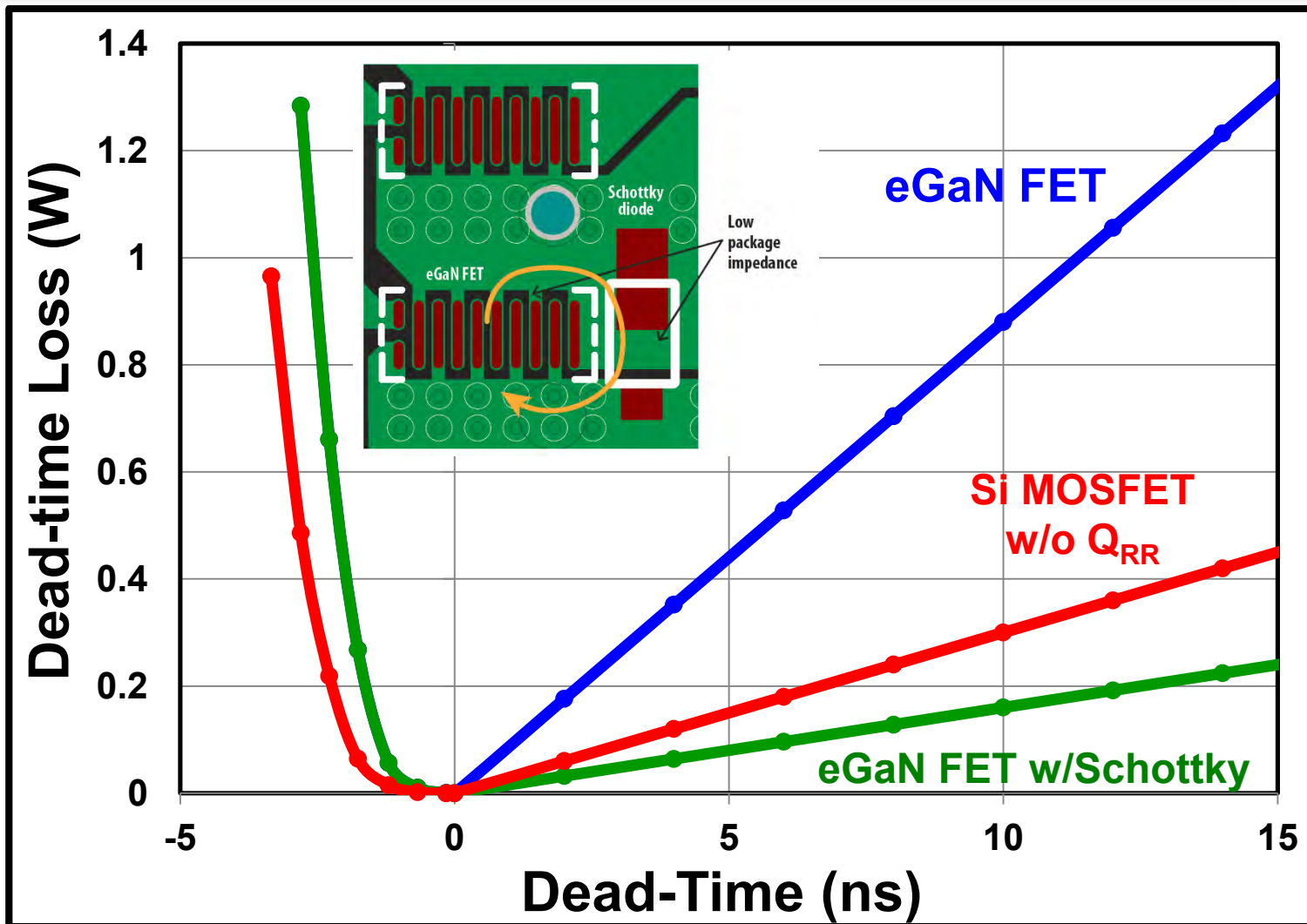
Dead-time Requirements





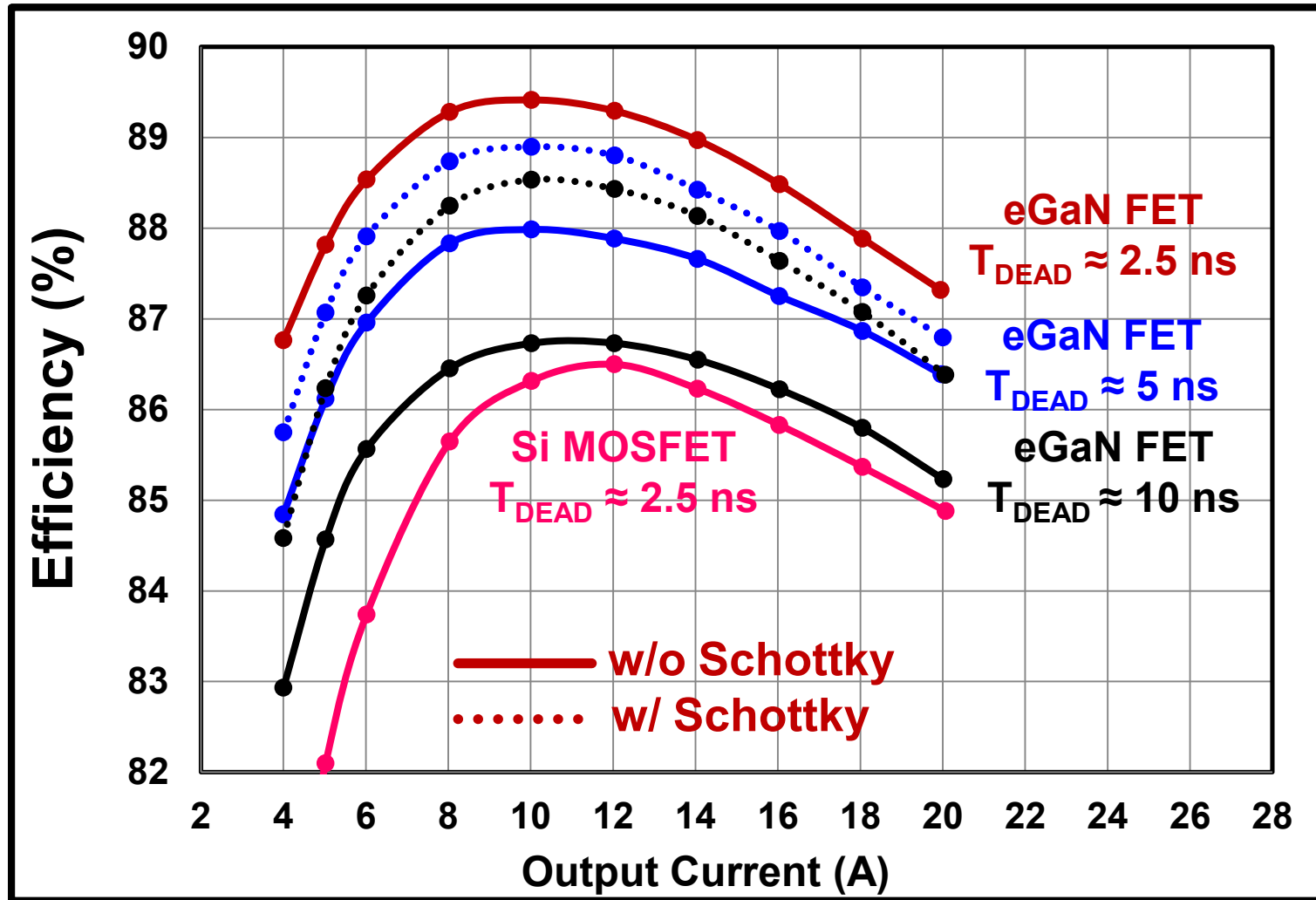


Impact of Dead-time

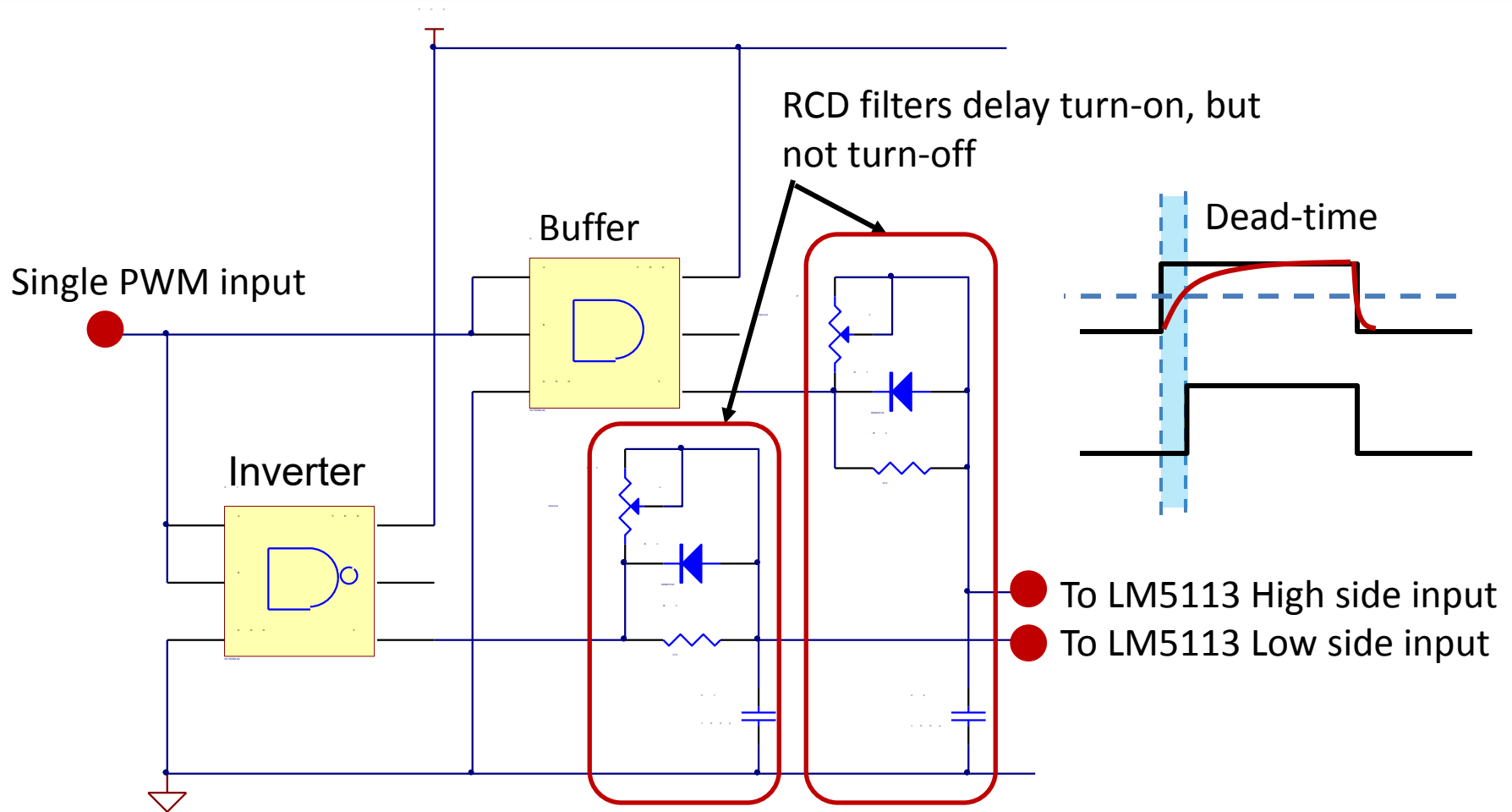


$V_{IN} = 12\text{ V}$, $V_{OUT} = 1.2\text{ V}$, $I_{OUT} = 20\text{ A}$, and $f_{sw} = 1\text{ MHz}$

Impact of Dead-time

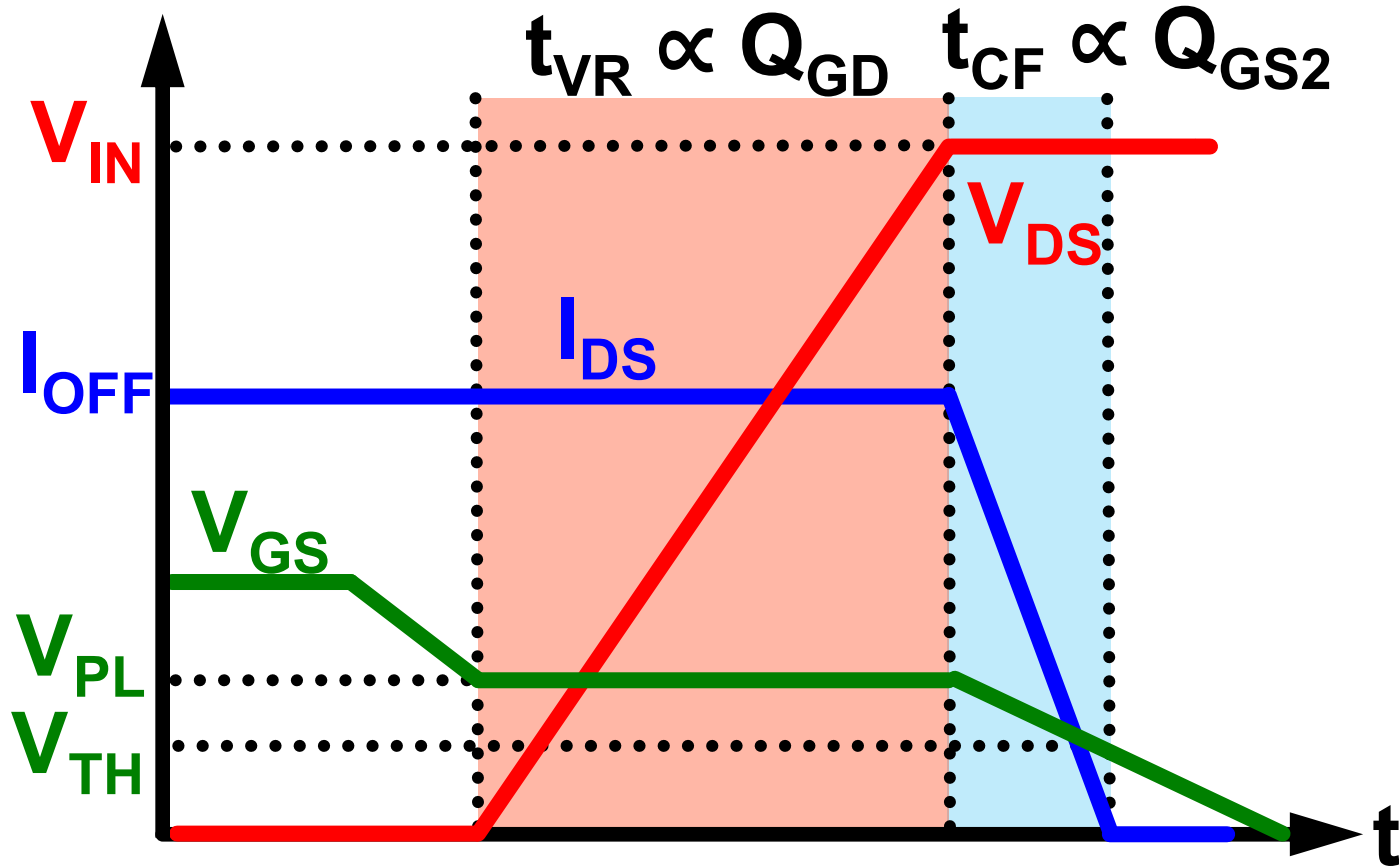


$V_{IN} = 12$ V, $V_{OUT} = 1.2$ V, and $f_{sw} = 1$ MHz



Used on all EPC90XX boards

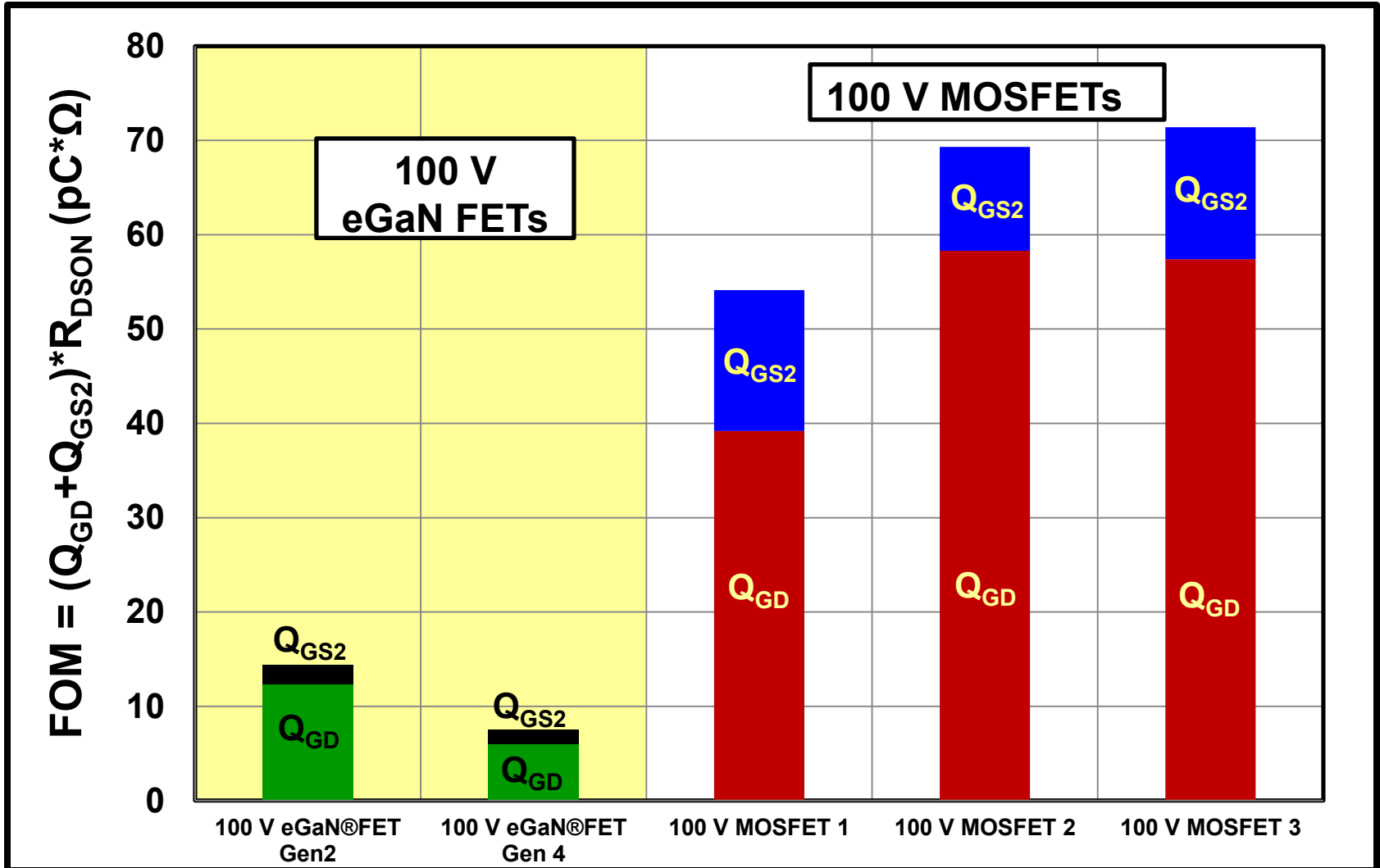
Layout



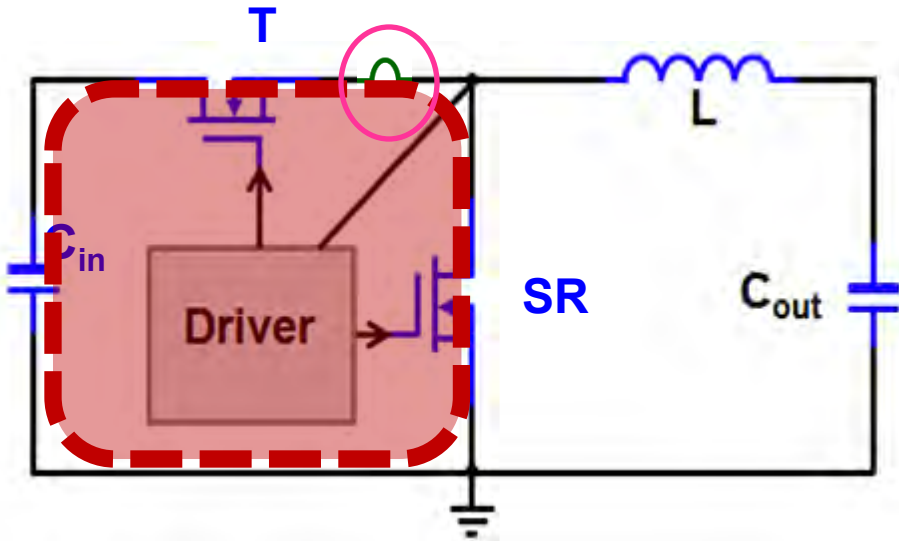
$$P_{t_{VR}} \approx \frac{V_{IN} * I_{OFF} * Q_{GD}}{2 * I_G}$$

$$P_{t_{CF}} \approx \frac{V_{IN} * I_{OFF} * Q_{GS2}}{2 * I_G}$$

100 V Device Comparison

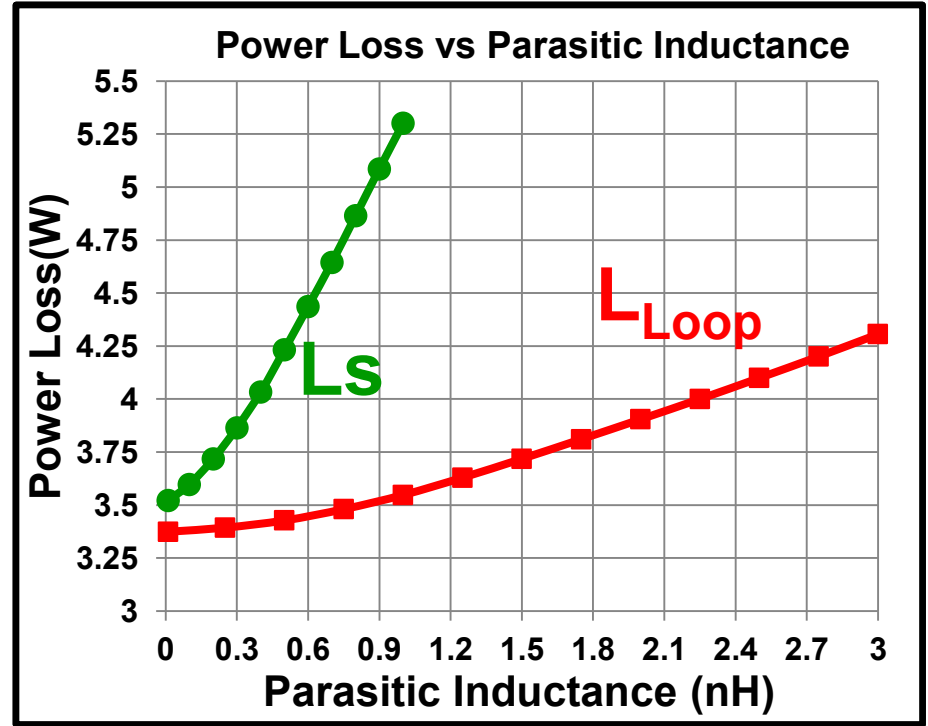


$V_{DS} = 0.5 * V_{DS}, I_{DS} = 10 A$

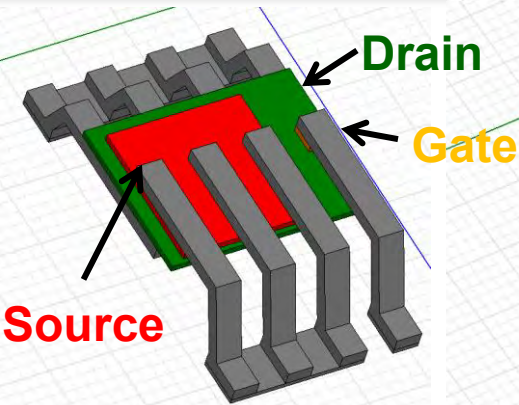


L_s : Common Source Inductance

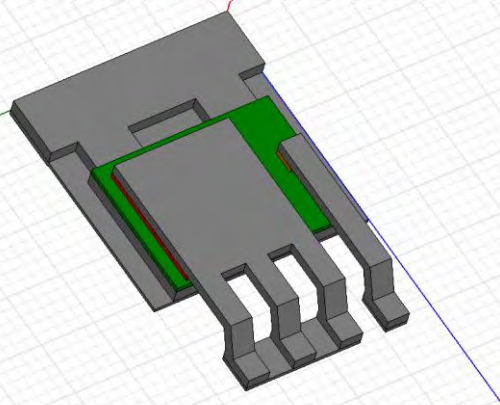
L_{Loop} : High Frequency Power Loop Inductance



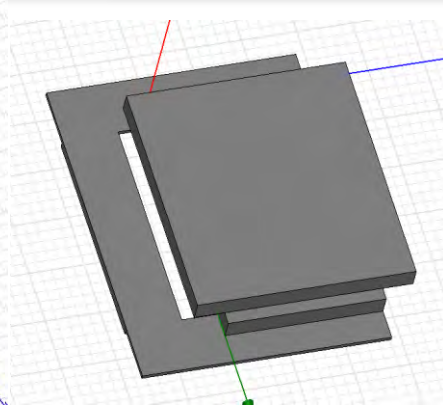
$V_{IN}=12\text{ V}$, $V_{OUT}=1.2\text{ V}$,
 $f_{sw}=1\text{ MHz}$, $I_{OUT}=20\text{ A}$



SO-8



LPAK

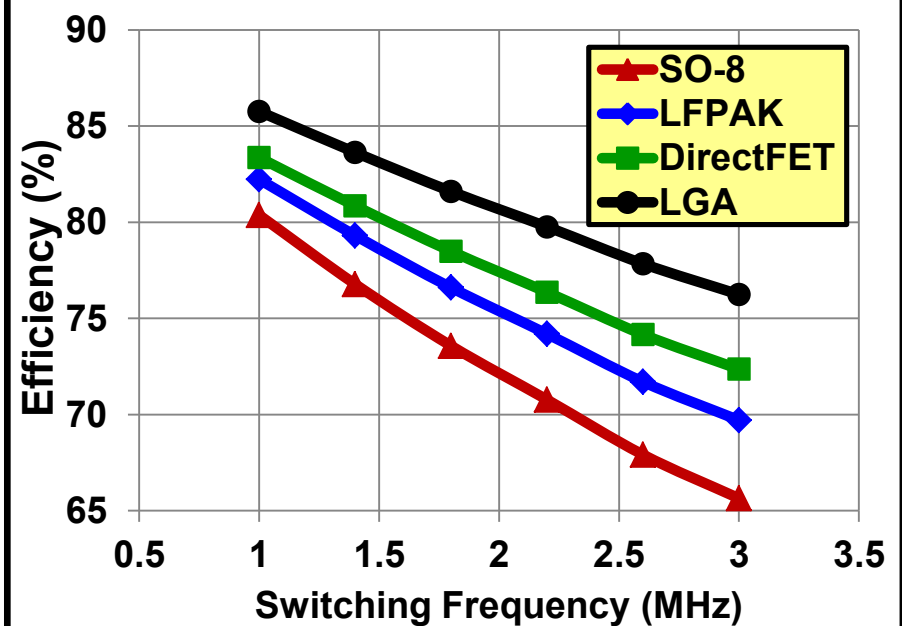
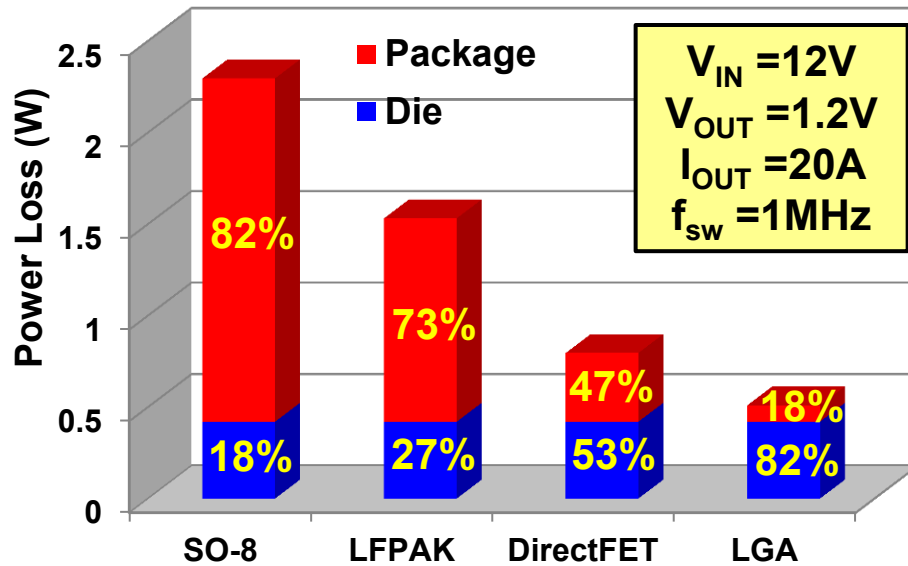


DirectFET

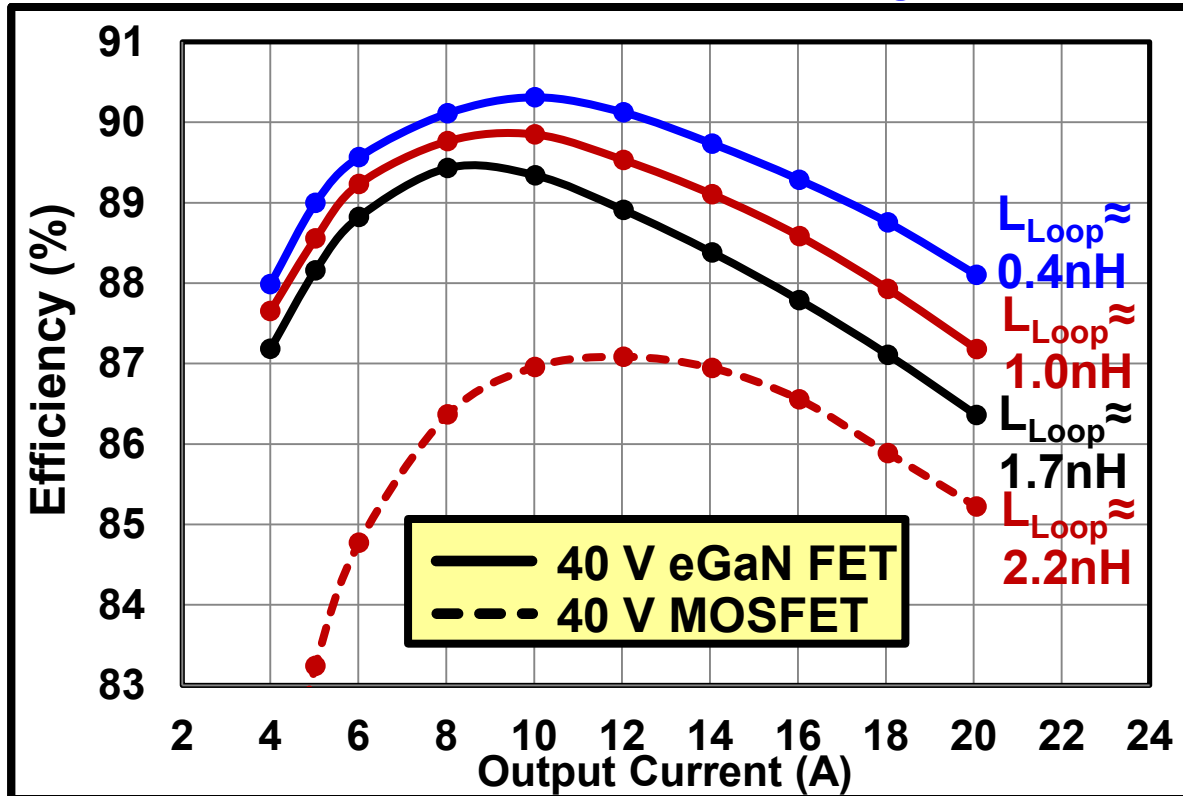


LGA eGaN FET

Device Loss Breakdown

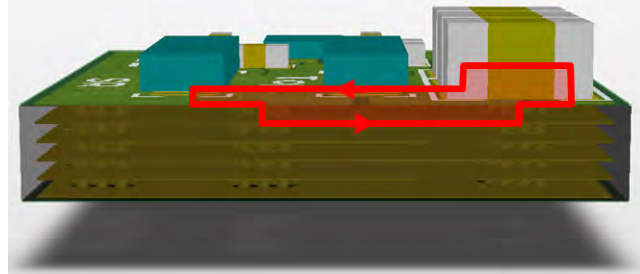


Measured Efficiency



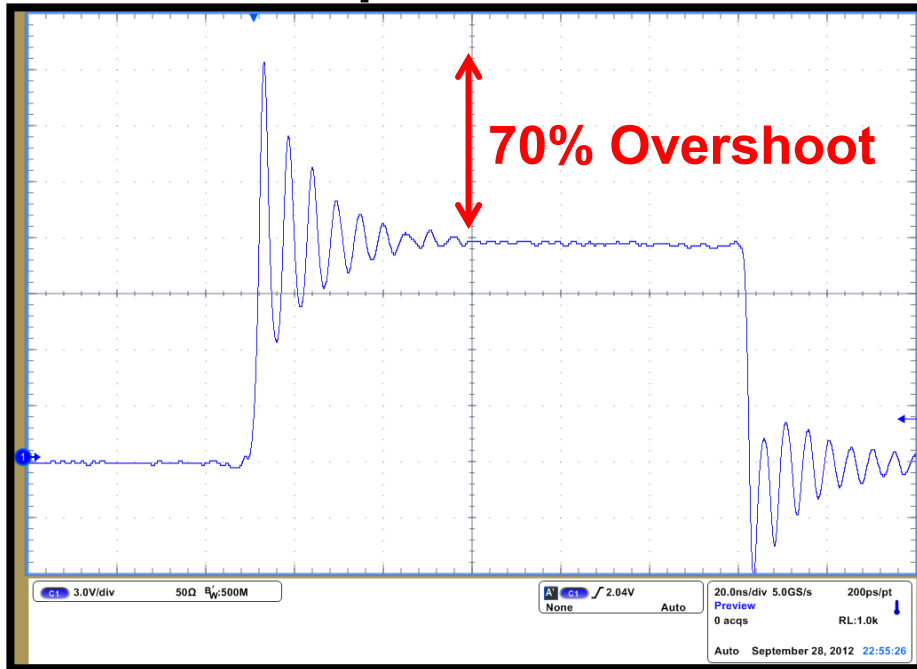
$V_{IN}=12\text{ V}$, $V_{OUT}=1.2\text{ V}$, $f_{sw}=1\text{ MHz}$, $L=300\text{ nH}$

EPC Optimal Layout

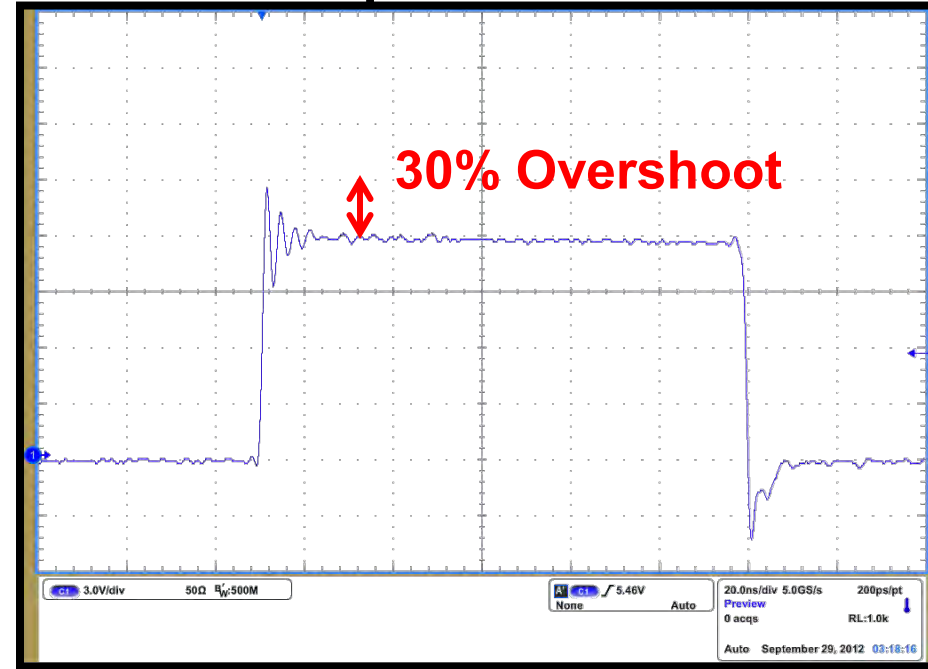


Ref: D. Reusch, J. Strydom,
 "Understanding the Effect of PCB Layout
 on Circuit Performance in a High
 Frequency Gallium Nitride Based Point of
 Load Converter," APEC 2013

$L_{Loop} \approx 1.0 \text{ nH}$



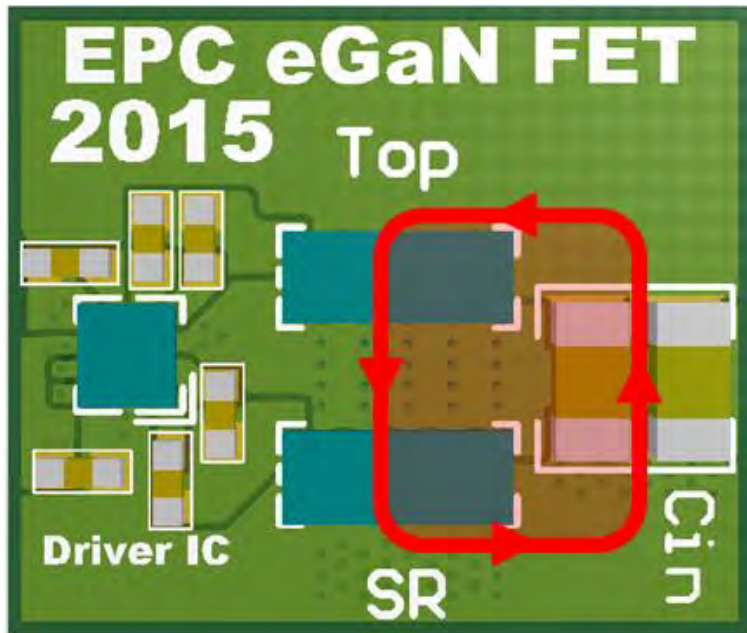
$L_{Loop} \approx 0.4 \text{ nH}$



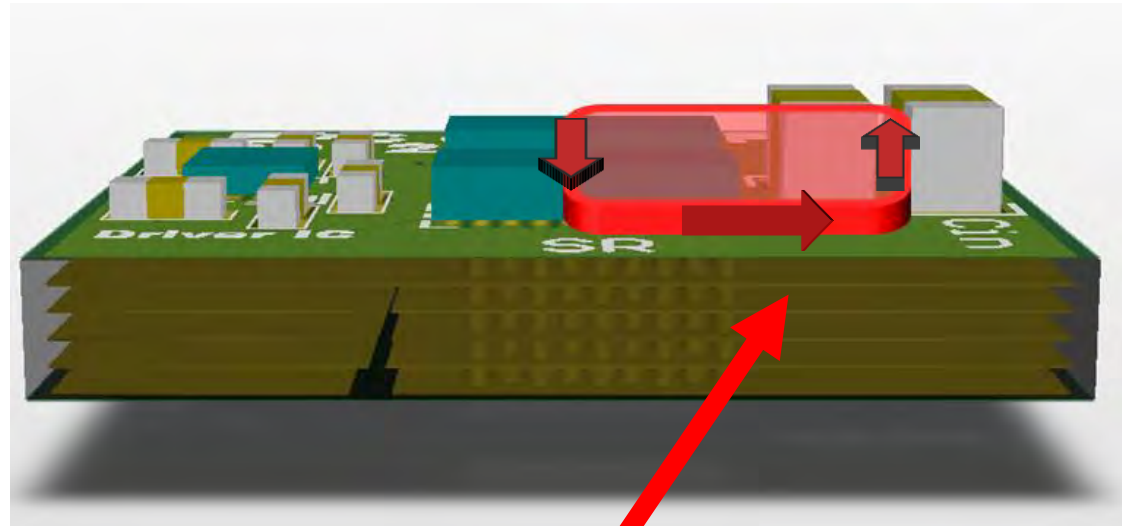
Switching Node Voltage

$V_{IN}=12 \text{ V } V_{OUT}=1.2 \text{ V } I_{OUT}=20 \text{ A}$
 $f_{sw}=1 \text{ MHz } L=150 \text{ nH}$

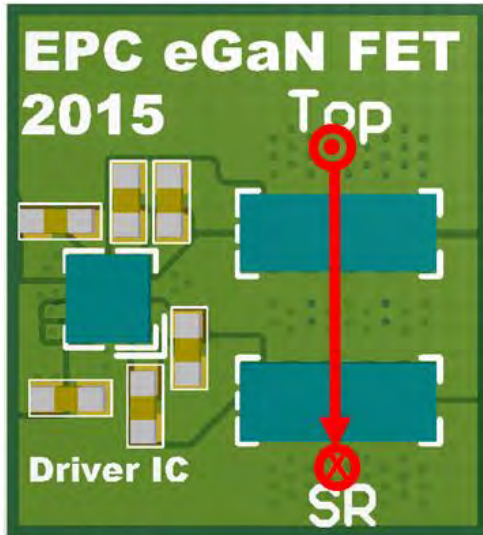
Top View



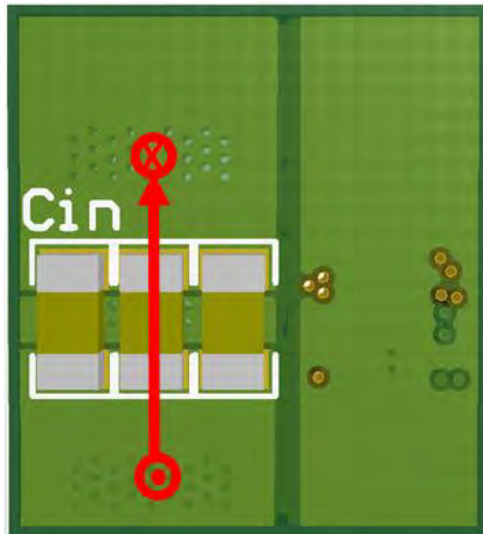
Side View



Shield Layer

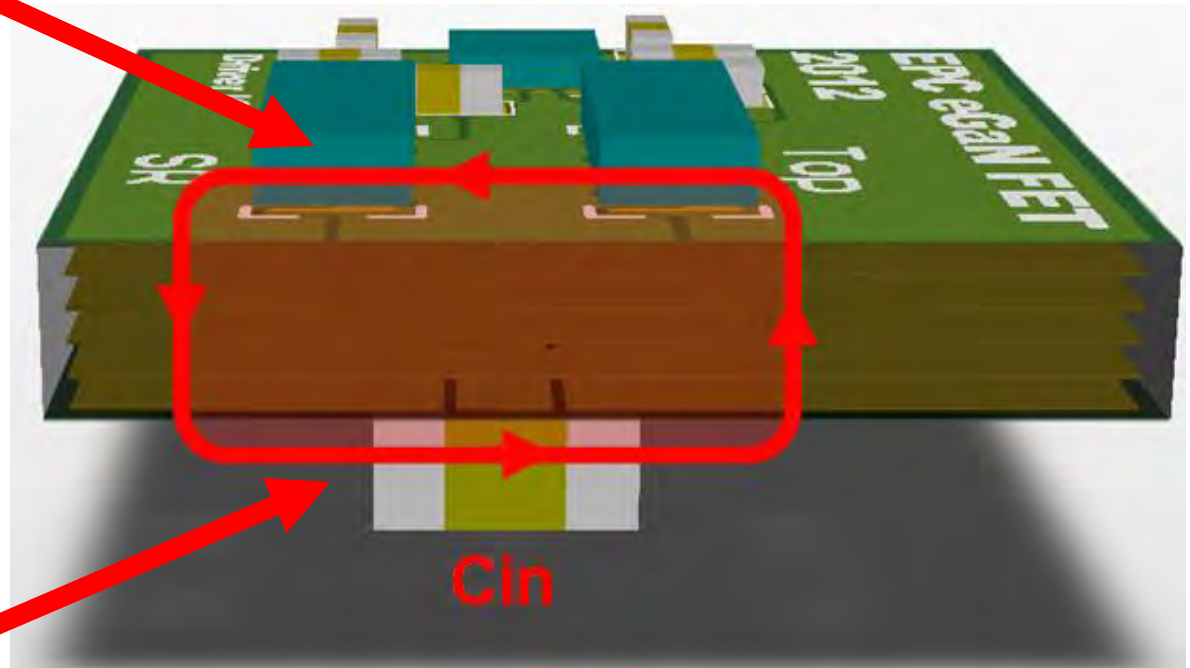


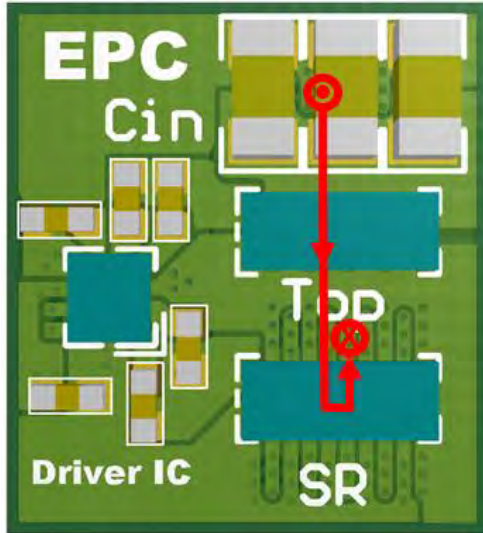
Top View



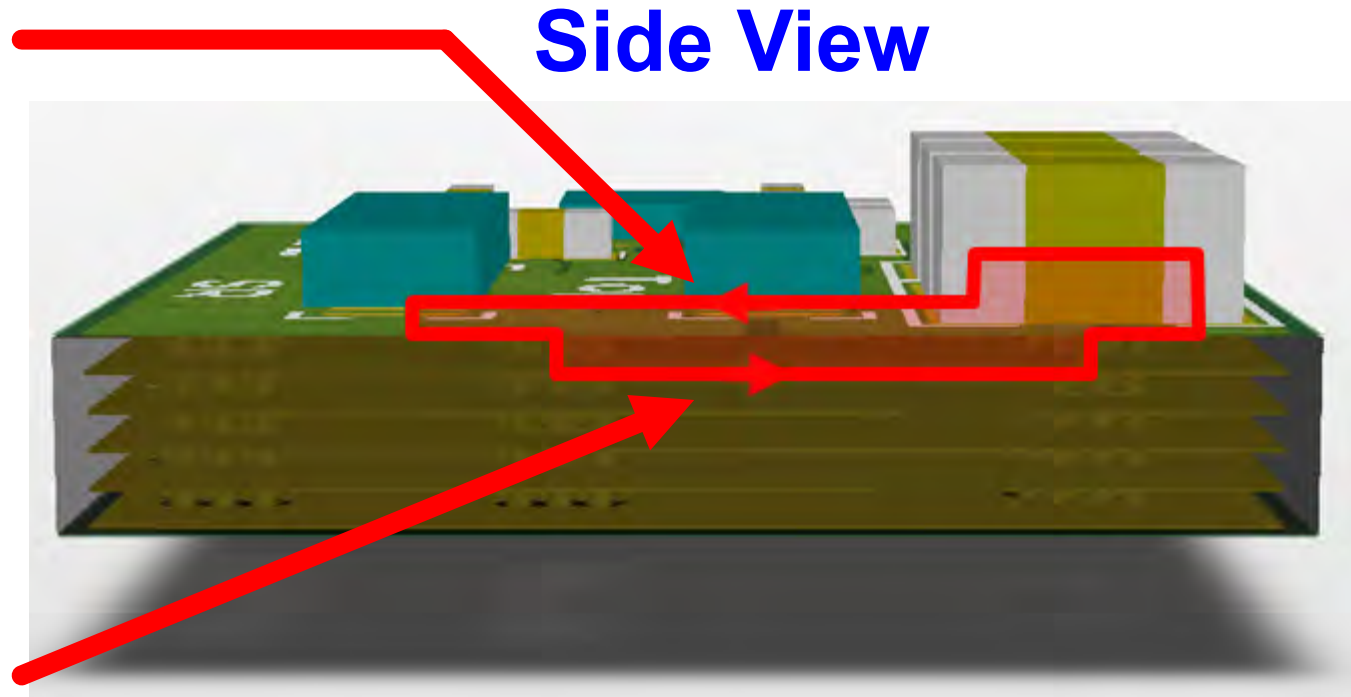
Bottom View

Side View

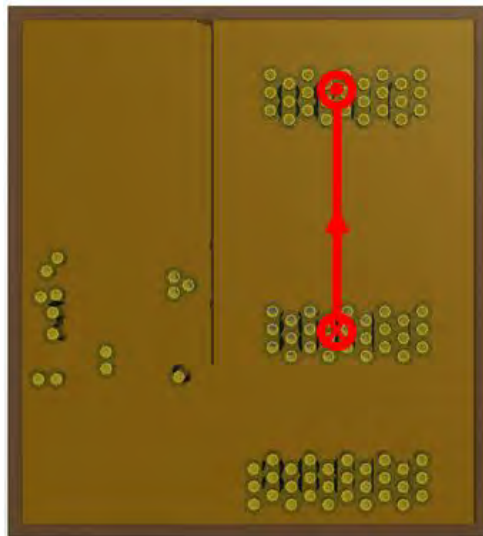




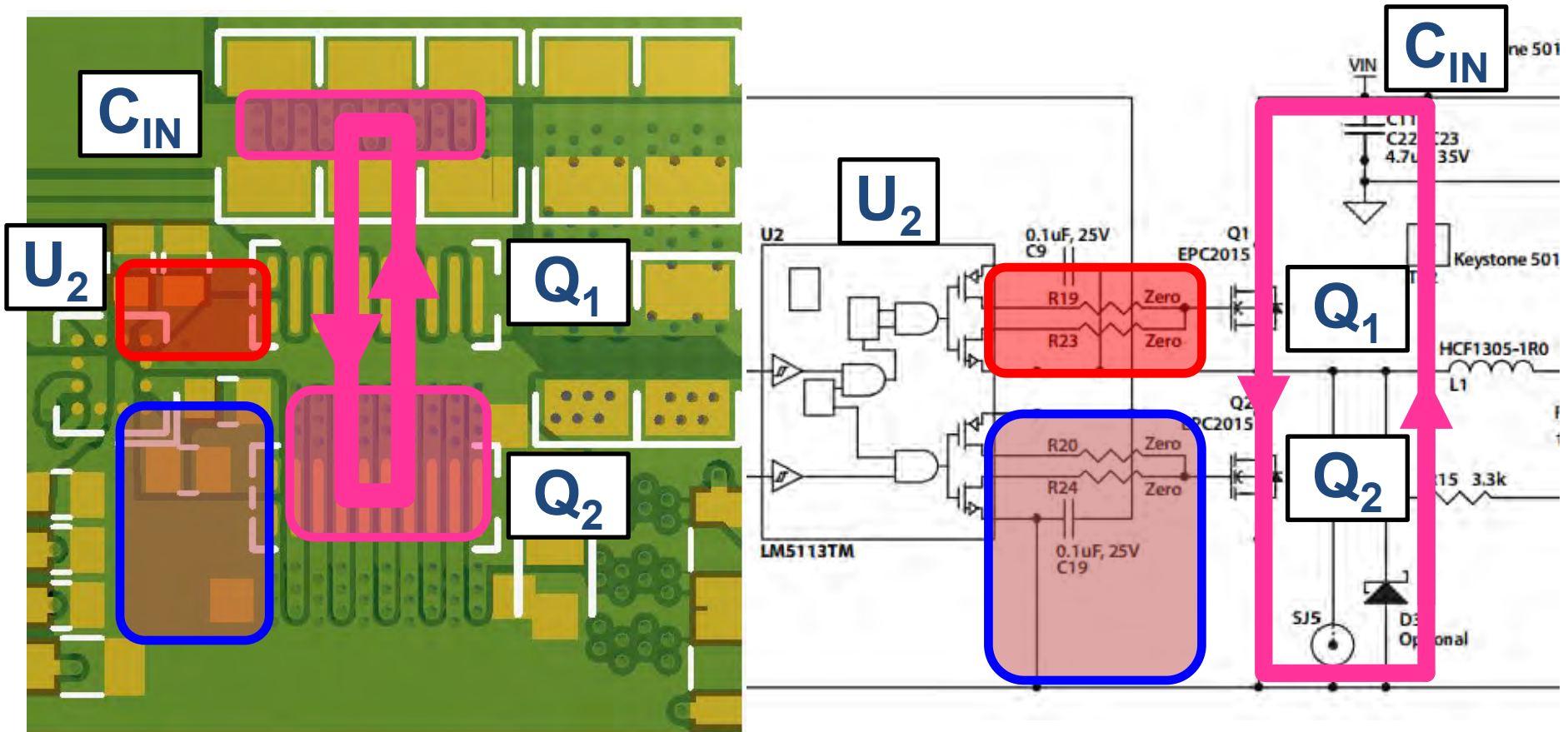
Top View

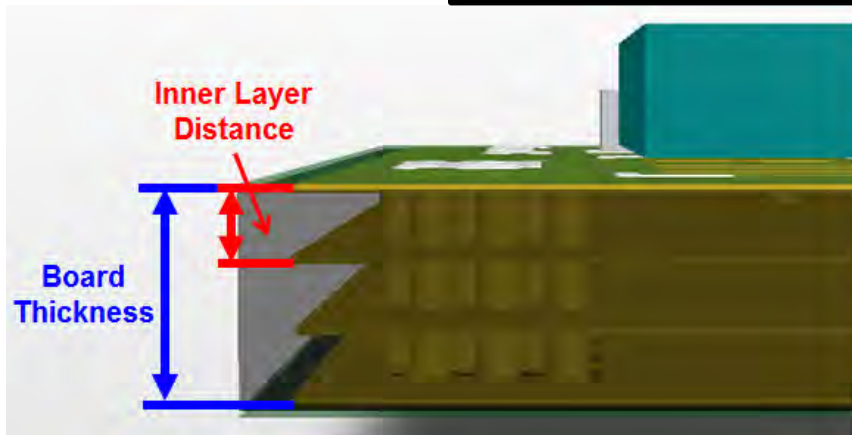
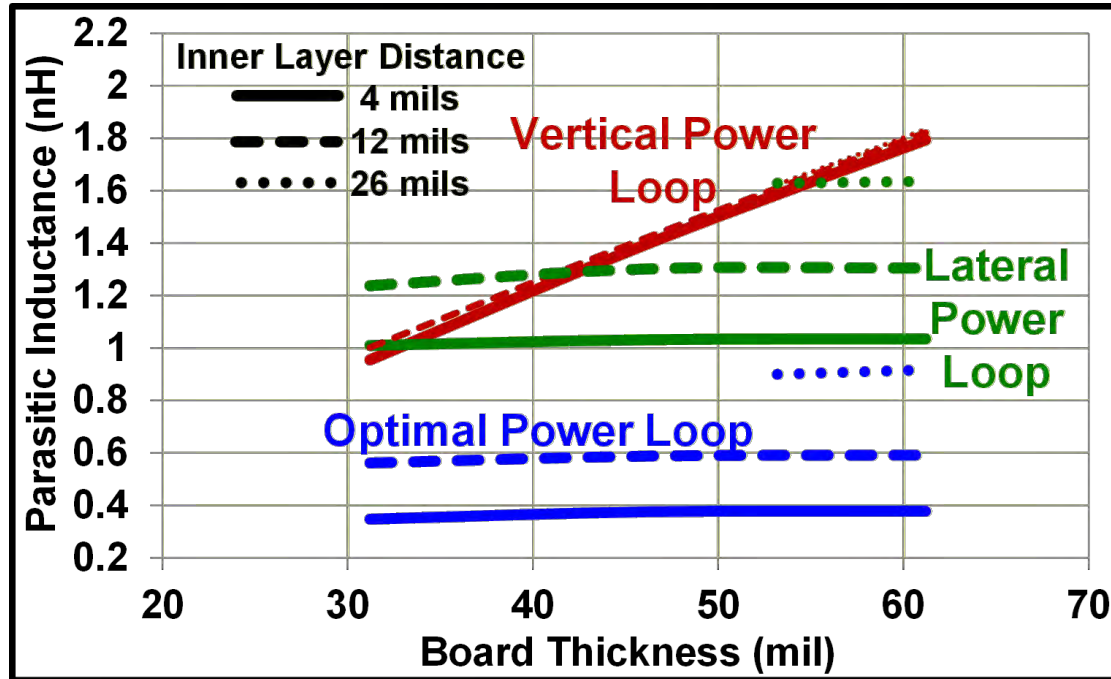


Side View



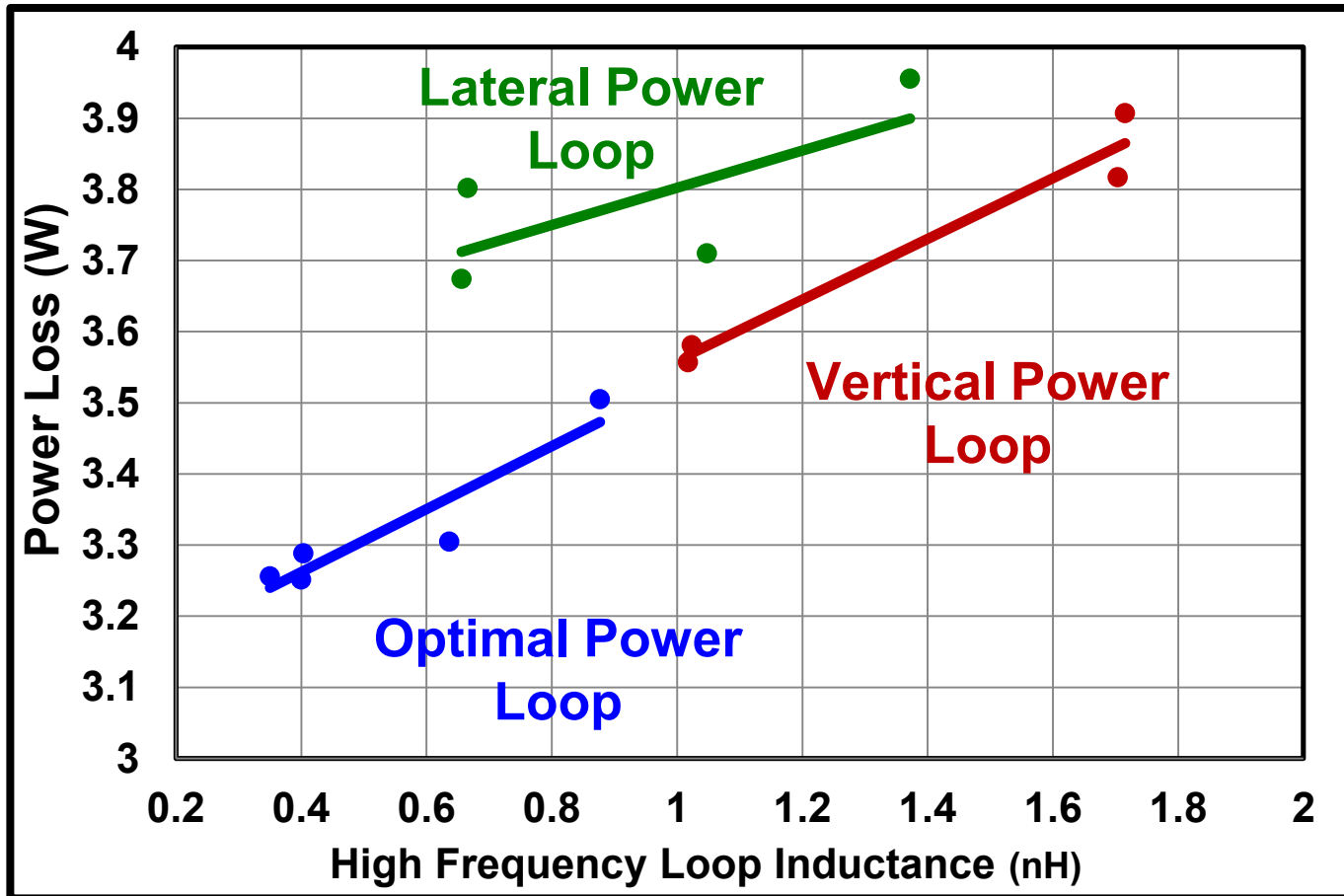
**Top View
Inner Layer 1**



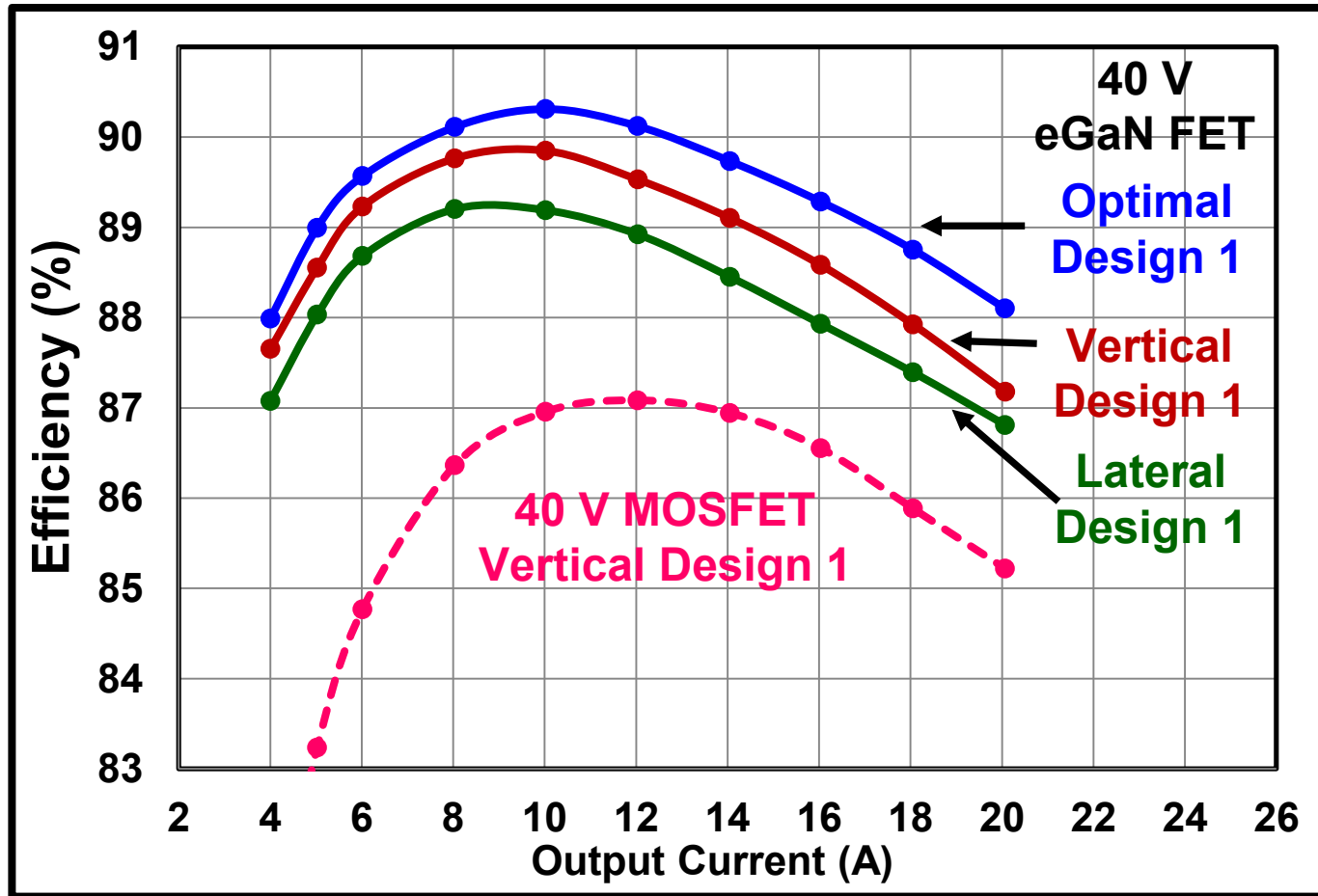


Test Cases

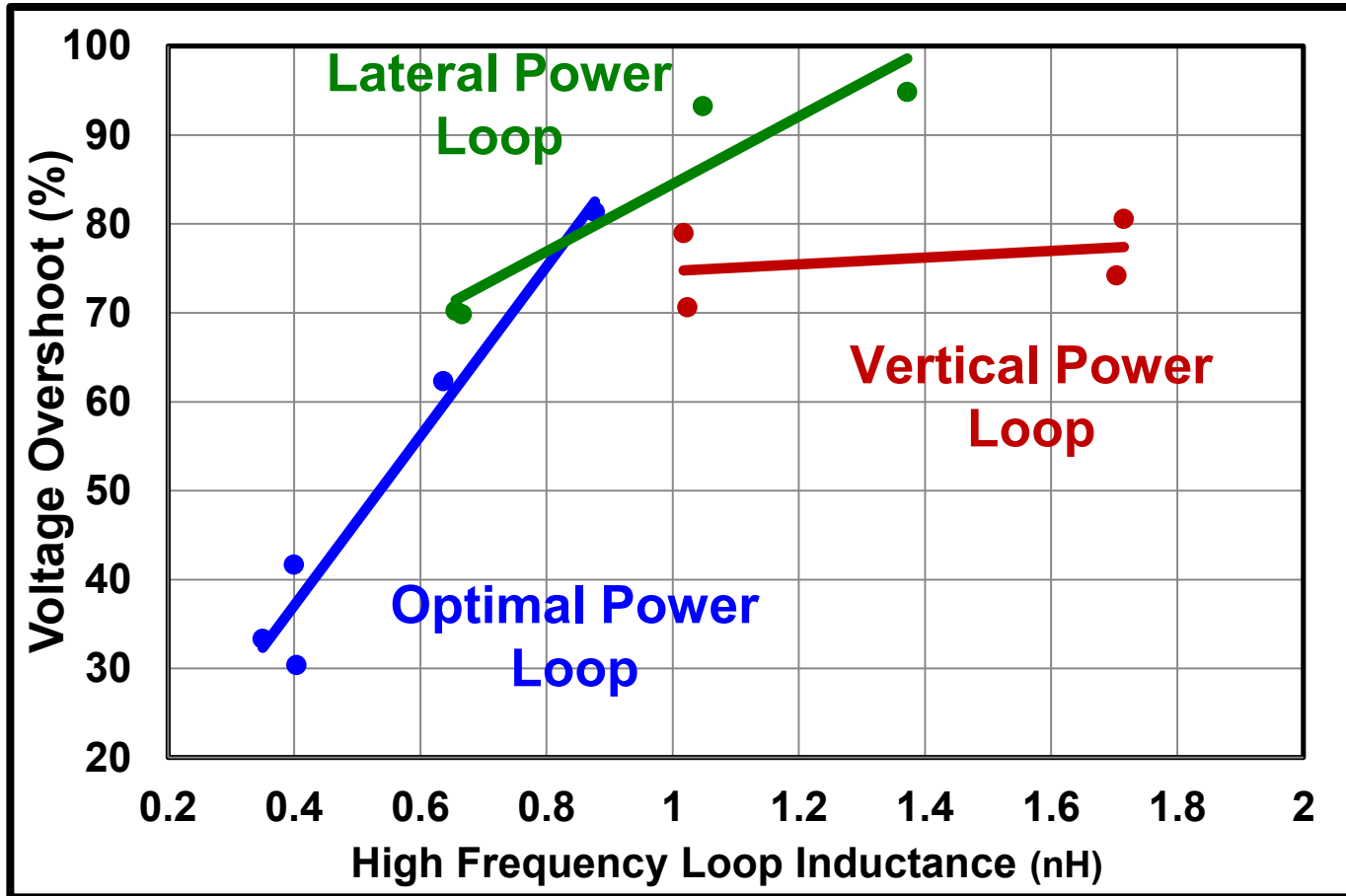
	Board Thickness (mils)	Inner Layer Distance (mils)
Design 1	31	4
Design 2	31	12
Design 3	62	4
Design 4	62	26



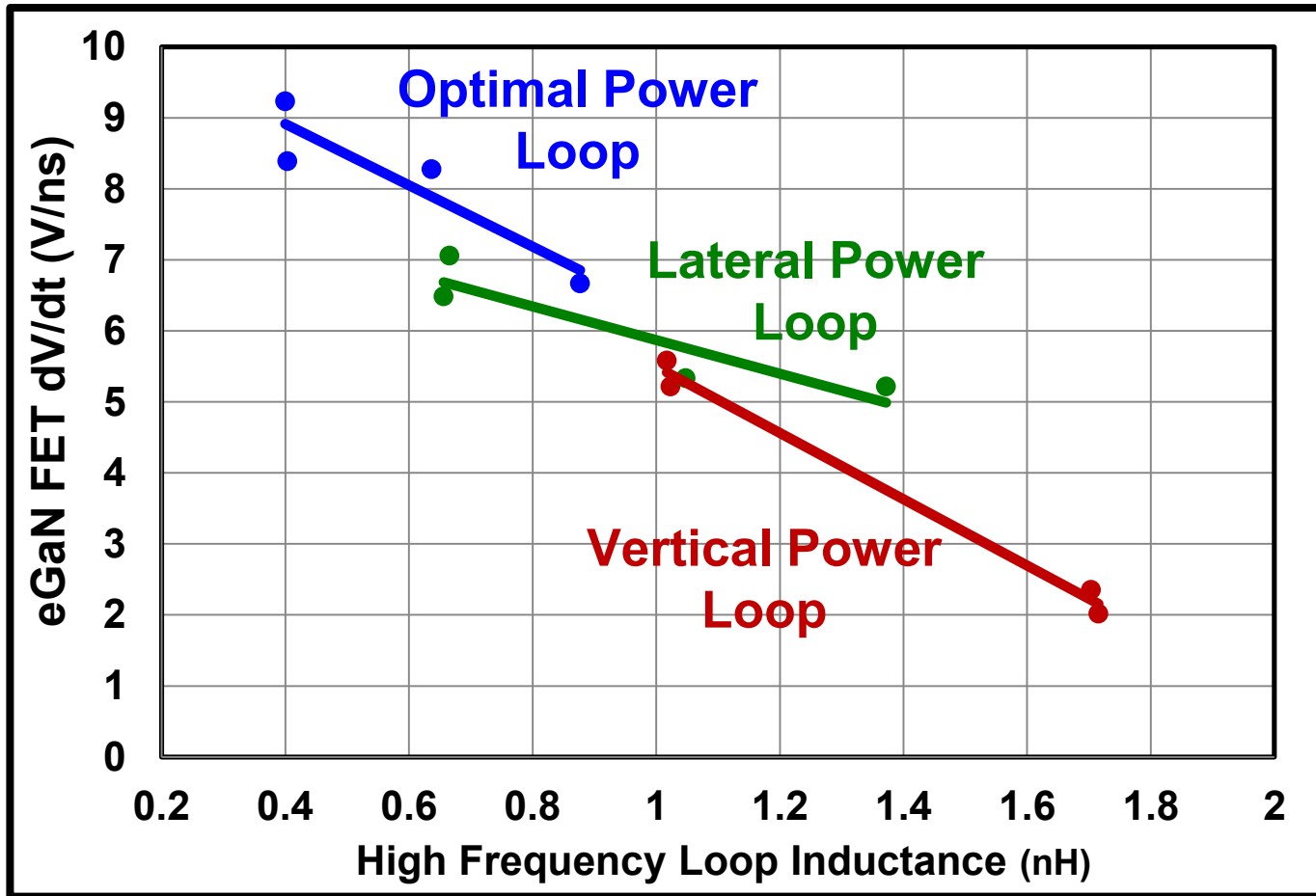
$V_{IN}=12\text{ V}$ $V_{OUT}=1.2\text{ V}$ $I_{OUT}=20\text{ A}$ $f_{sw}=1\text{ MHz}$ $L=300\text{ nH}$
T/SR: EPC2015 Driver LM5113



$V_{IN}=12\text{ V}$ $V_{OUT}=1.2\text{ V}$ $f_{sw}=1\text{ MHz}$ $L=300\text{ nH}$
GaN T/SR: EPC2015 Driver LM5113

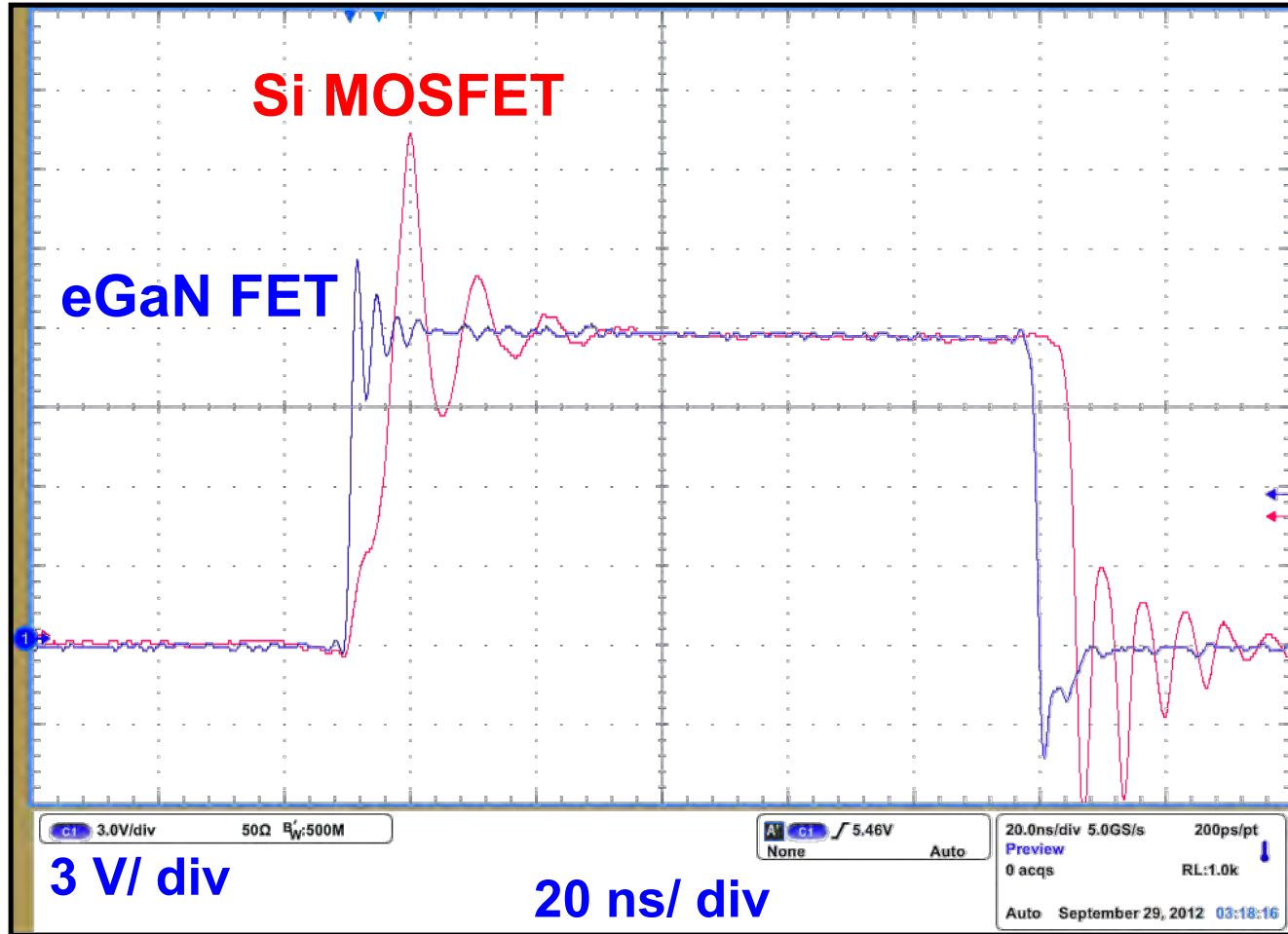


$V_{IN}=12\text{ V}$ $V_{OUT}=1.2\text{ V}$ $I_{OUT}=20\text{ A}$ $f_{sw}=1\text{ MHz}$ $L=300\text{ nH}$
T/SR: EPC2015 Driver LM5113

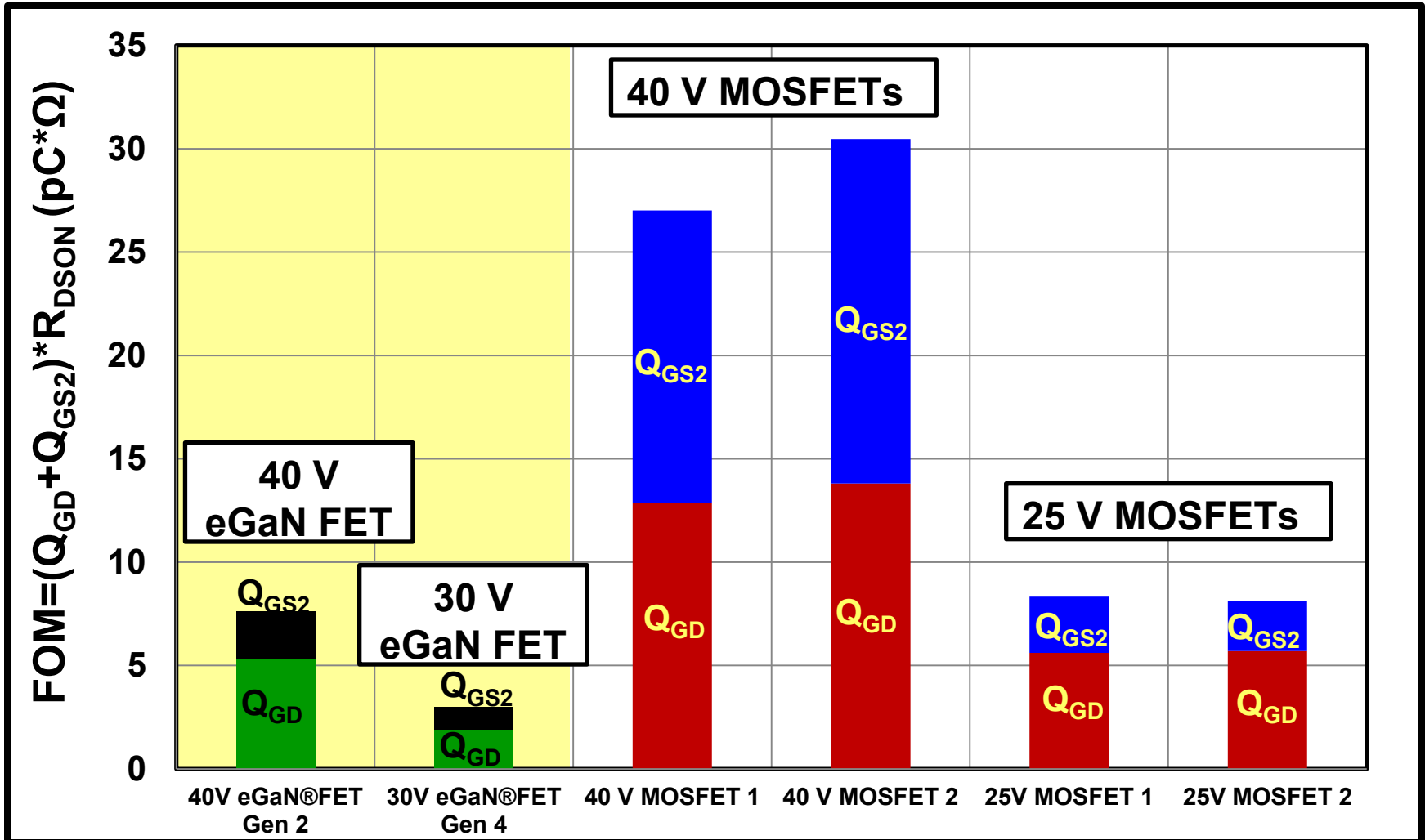


$V_{IN}=12\text{ V}$ $V_{OUT}=1.2\text{ V}$ $I_{OUT}=20\text{ A}$ $f_{sw}=1\text{ MHz}$ $L=300\text{ nH}$
T/SR: EPC2015 Driver LM5113

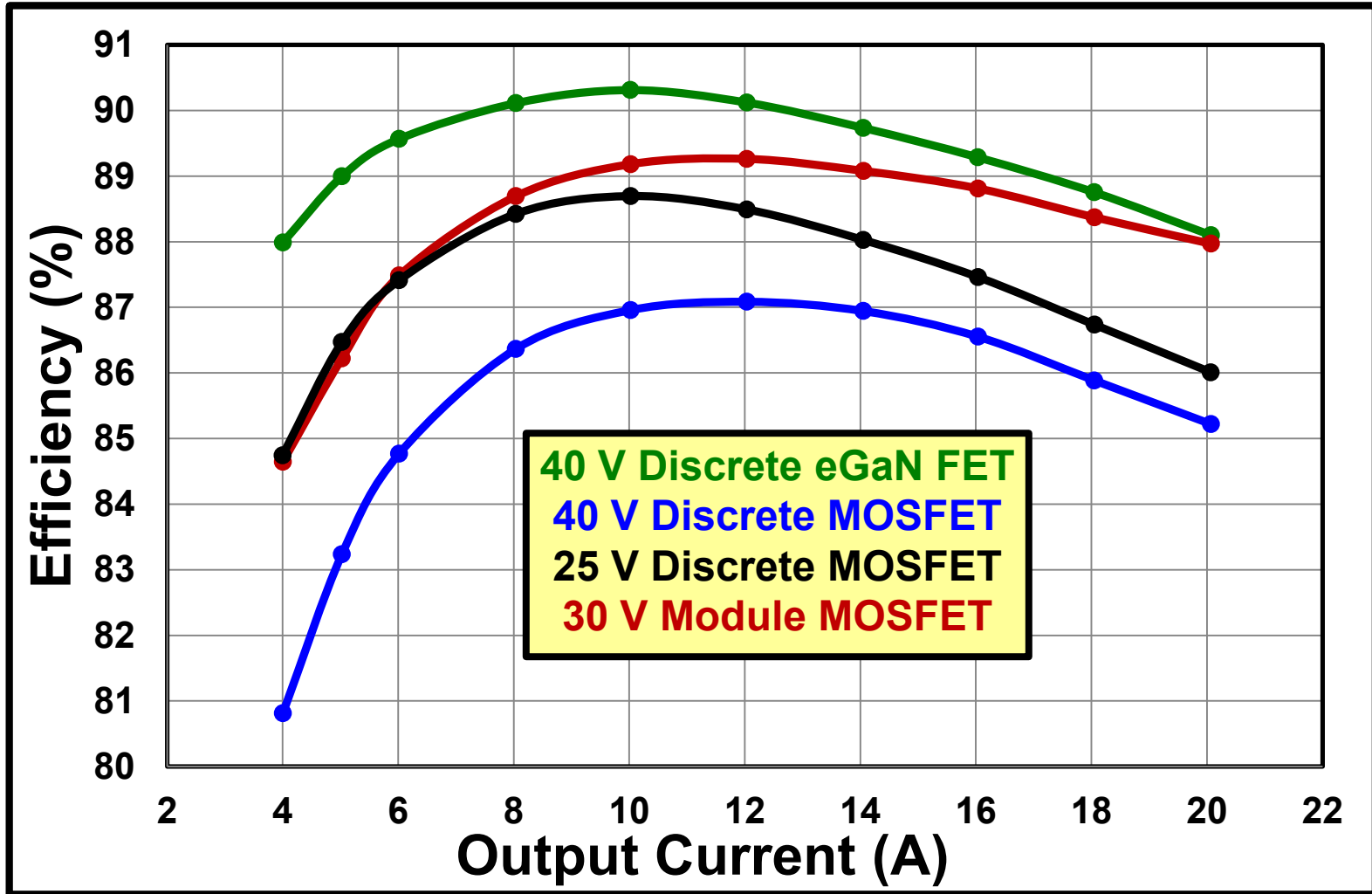
eGaN FET vs. MOSFET



$V_{IN}=12\text{ V}$ $V_{OUT}=1.2\text{ V}$ $I_{OUT}=20\text{ A}$ $f_{sw}=1\text{ MHz}$ $L=300\text{ nH}$ eGaN FET
T/SR: EPC2015 MOSFET T:BSZ097N04 SR:BSZ040N04

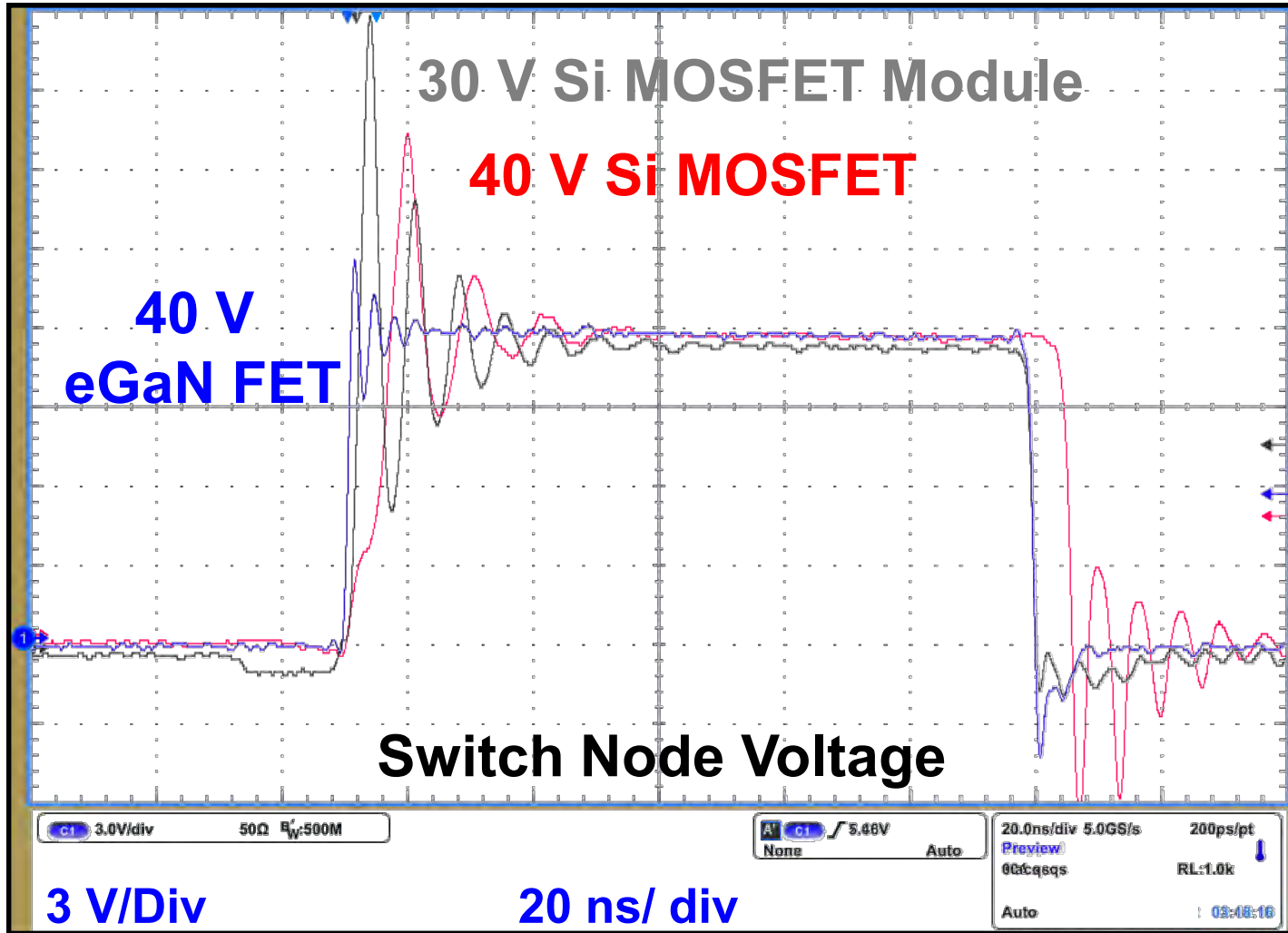


Lower Voltage Comparison

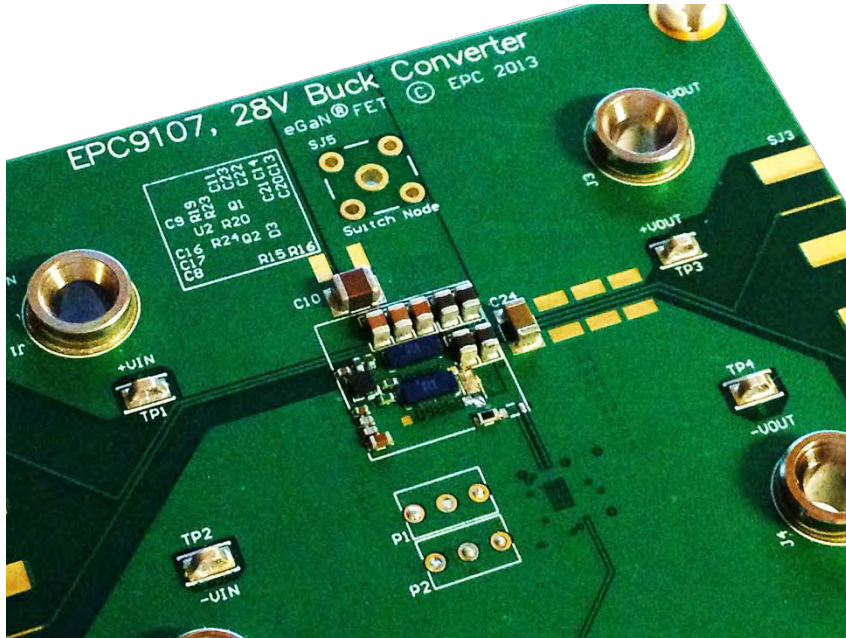


$V_{IN}=12\text{ V}$ $V_{OUT}=1.2\text{ V}$ $f_{sw}=1\text{ MHz}$ $L=300\text{ nH}$

Switching Comparison



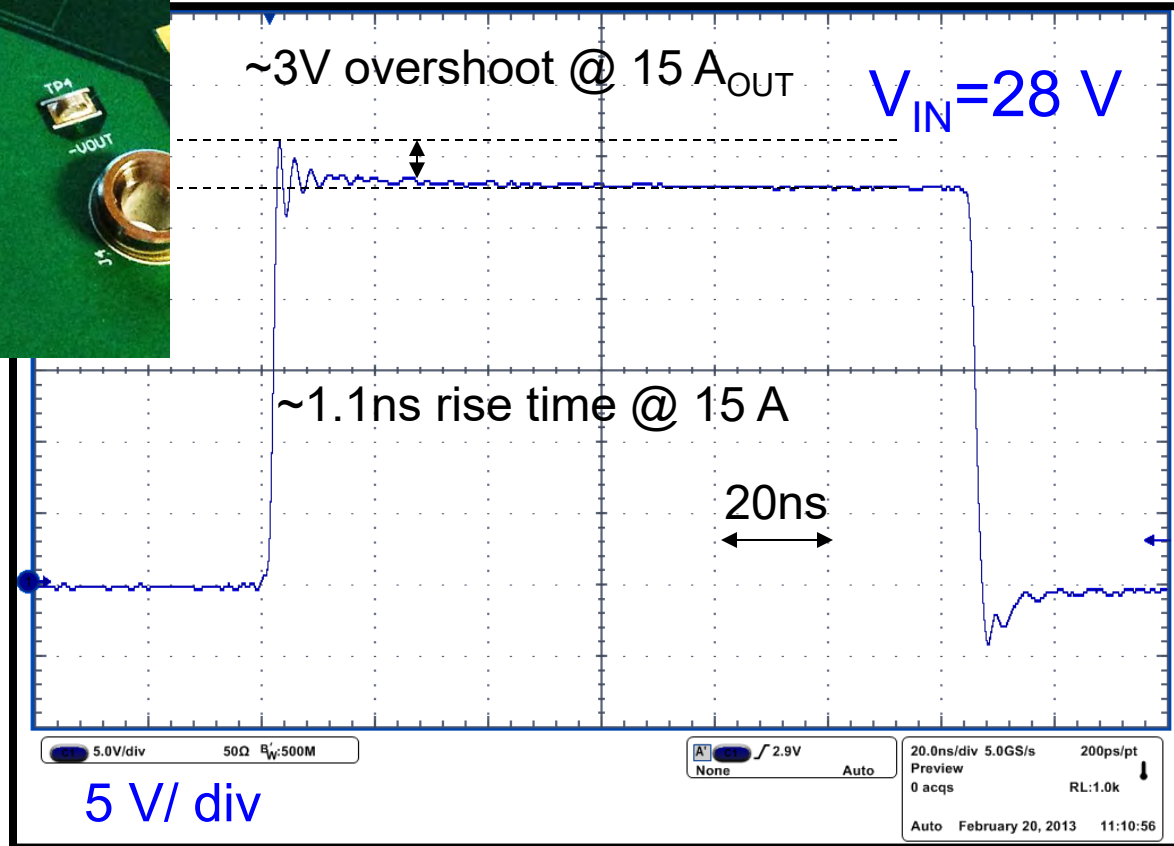
$V_{IN}=12\text{ V}$ $V_{OUT}=1.2\text{ V}$ $I_{OUT}=20\text{ A}$ $f_{sw}=1\text{ MHz}$ $L=300\text{ nH}$



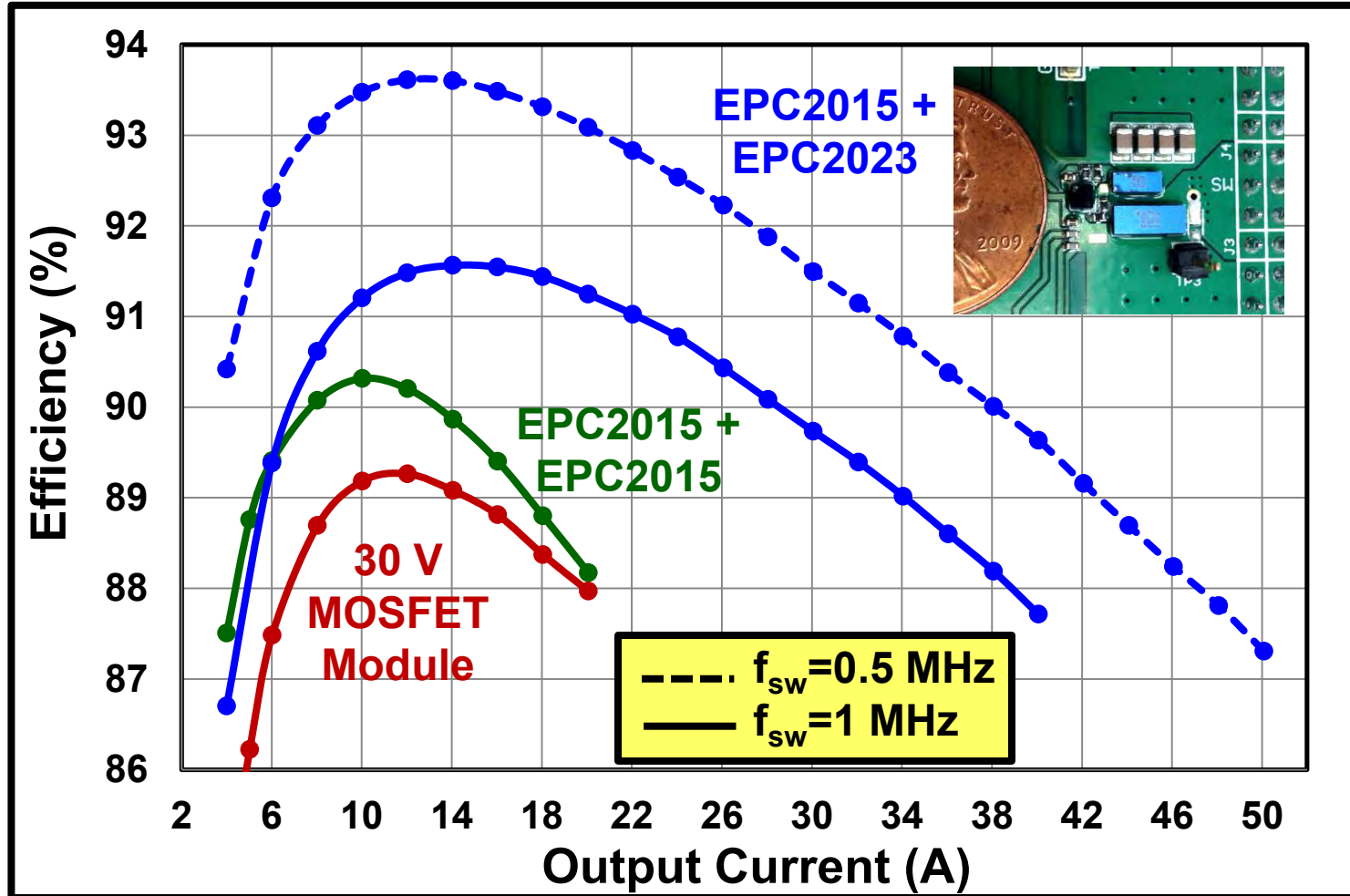
$V_{IN} = 12-28\text{ V}$ $V_{OUT} = 3.3\text{ V}$
 $I_{OUT} = 15\text{ A}$ $f_{sw} = 1\text{ MHz}$
 2 x EPC2015

Switching Node Voltage

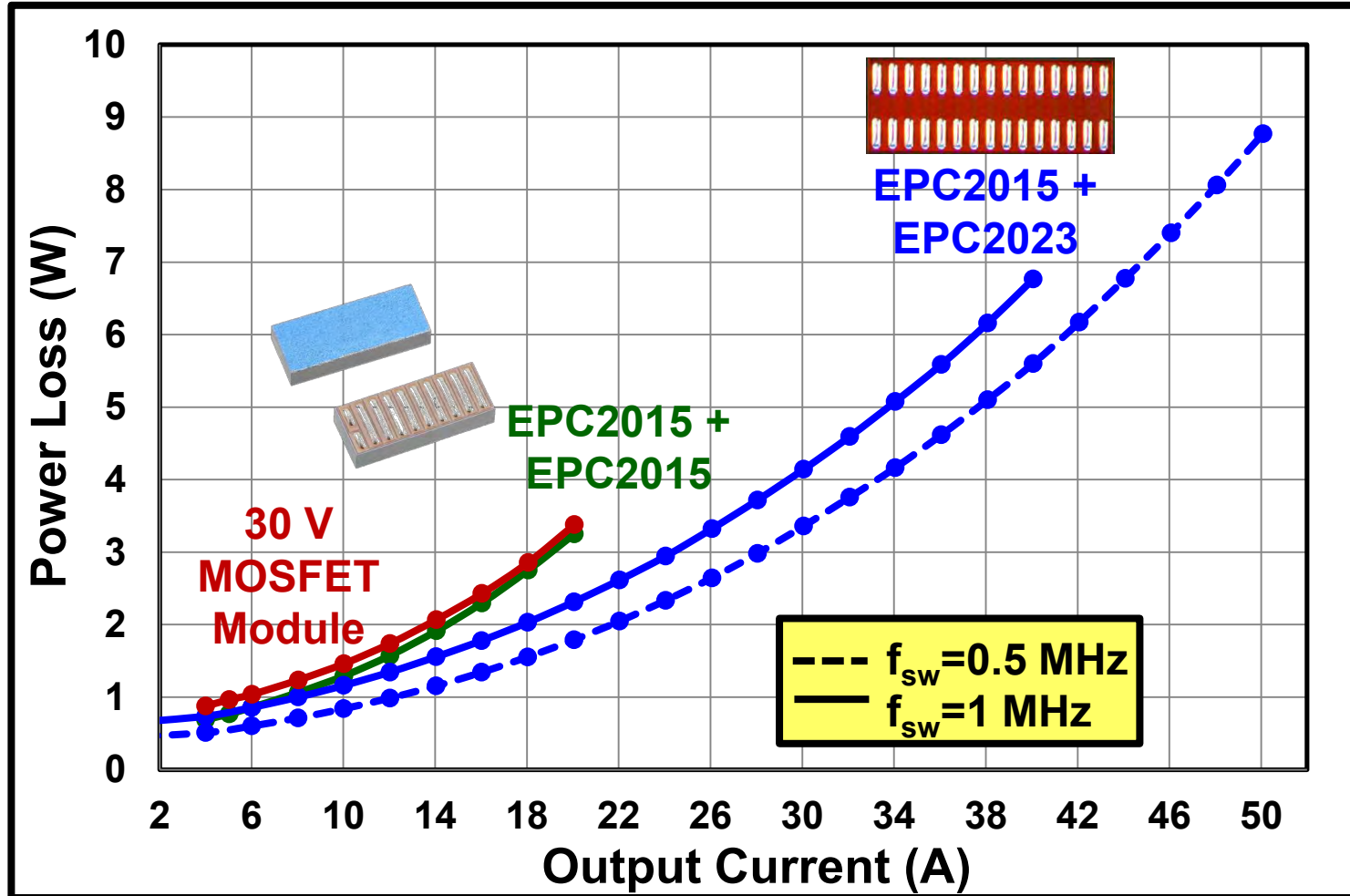
$V_{IN} = 28\text{ V}$, $I_{OUT} = 15\text{ A}$



Higher Current Devices

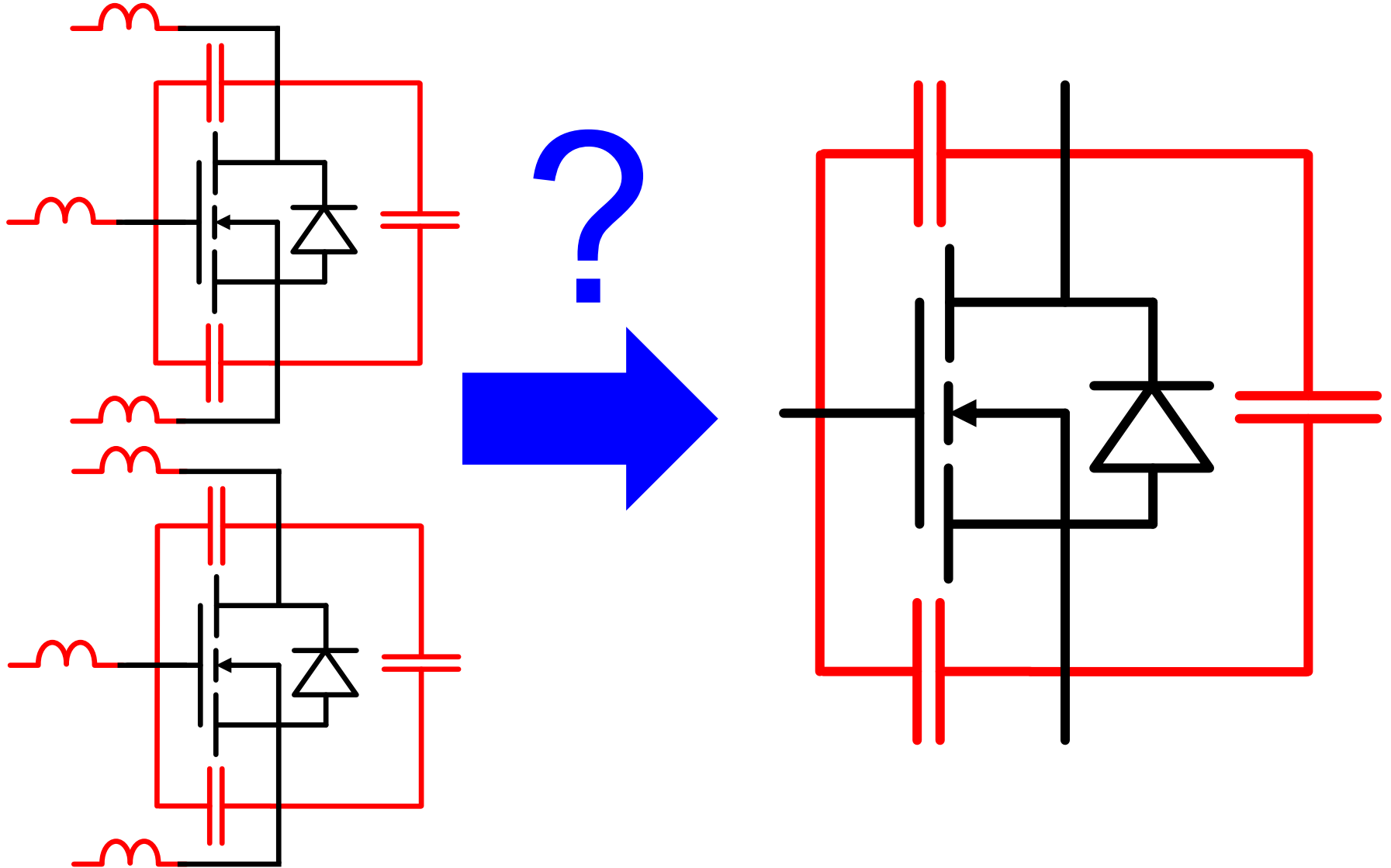


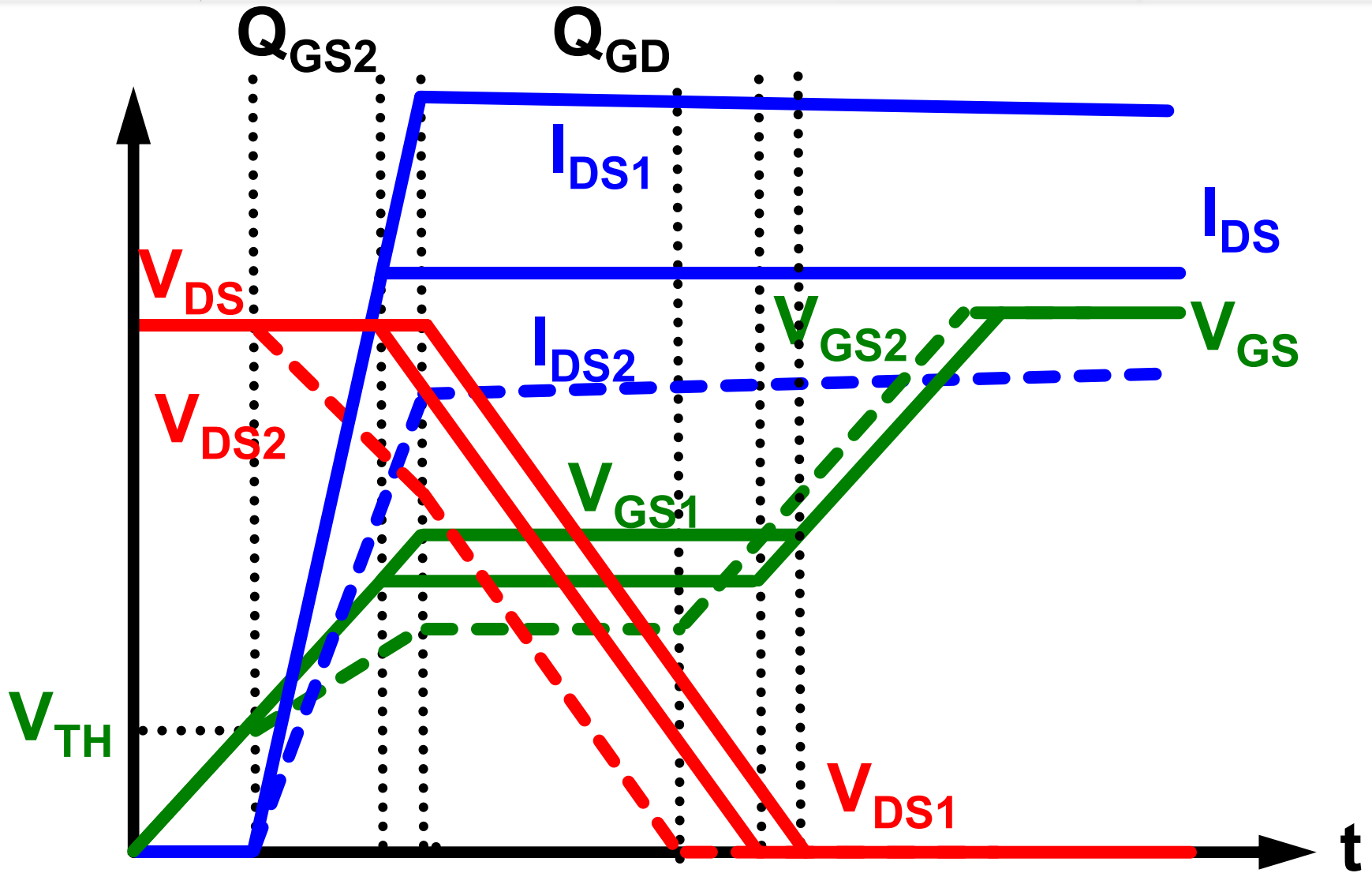
$V_{IN} = 12$ V $V_{OUT} = 1.2$ V

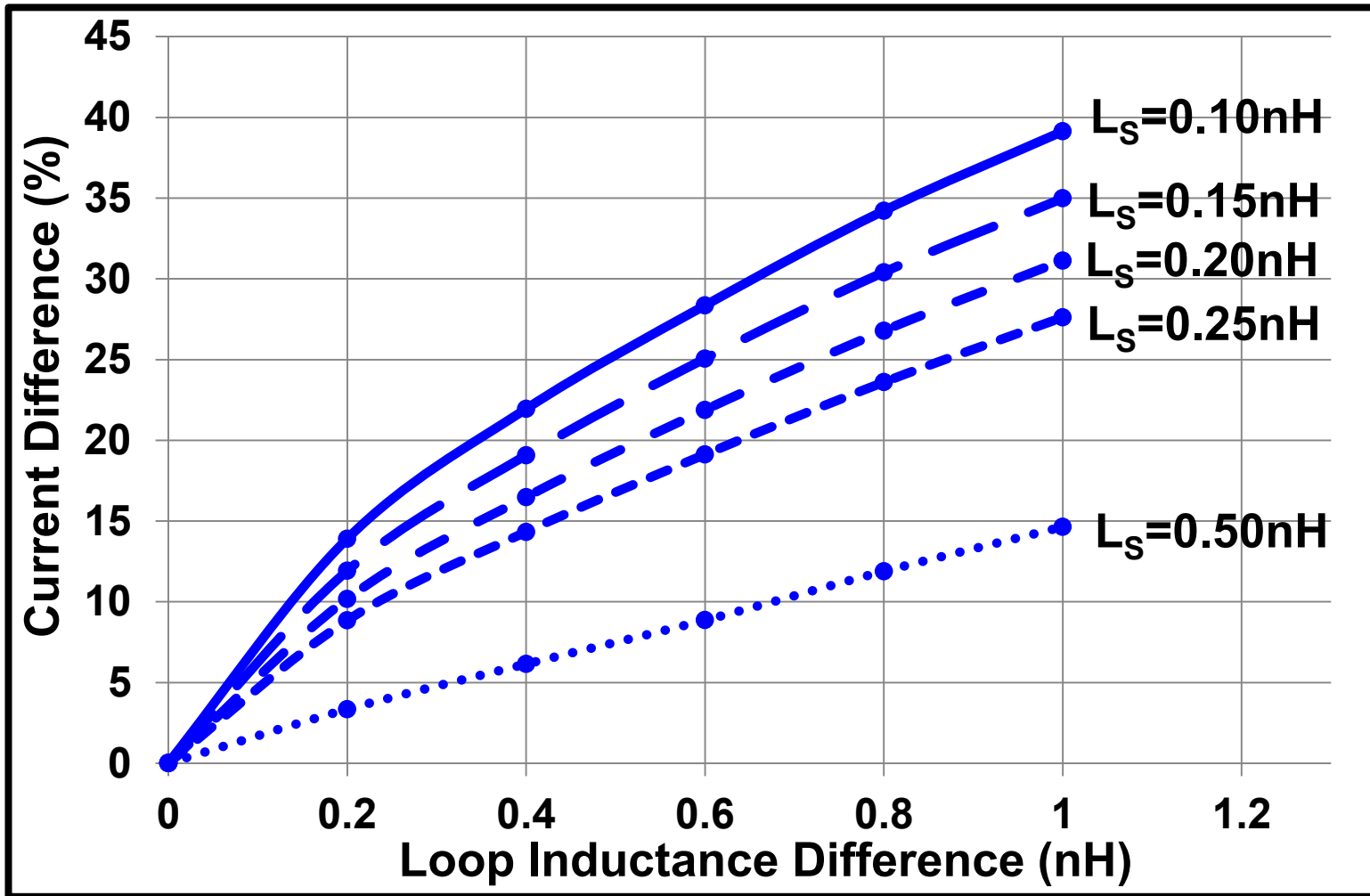


$V_{IN}=12\text{ V}$ $V_{OUT}=1.2\text{ V}$

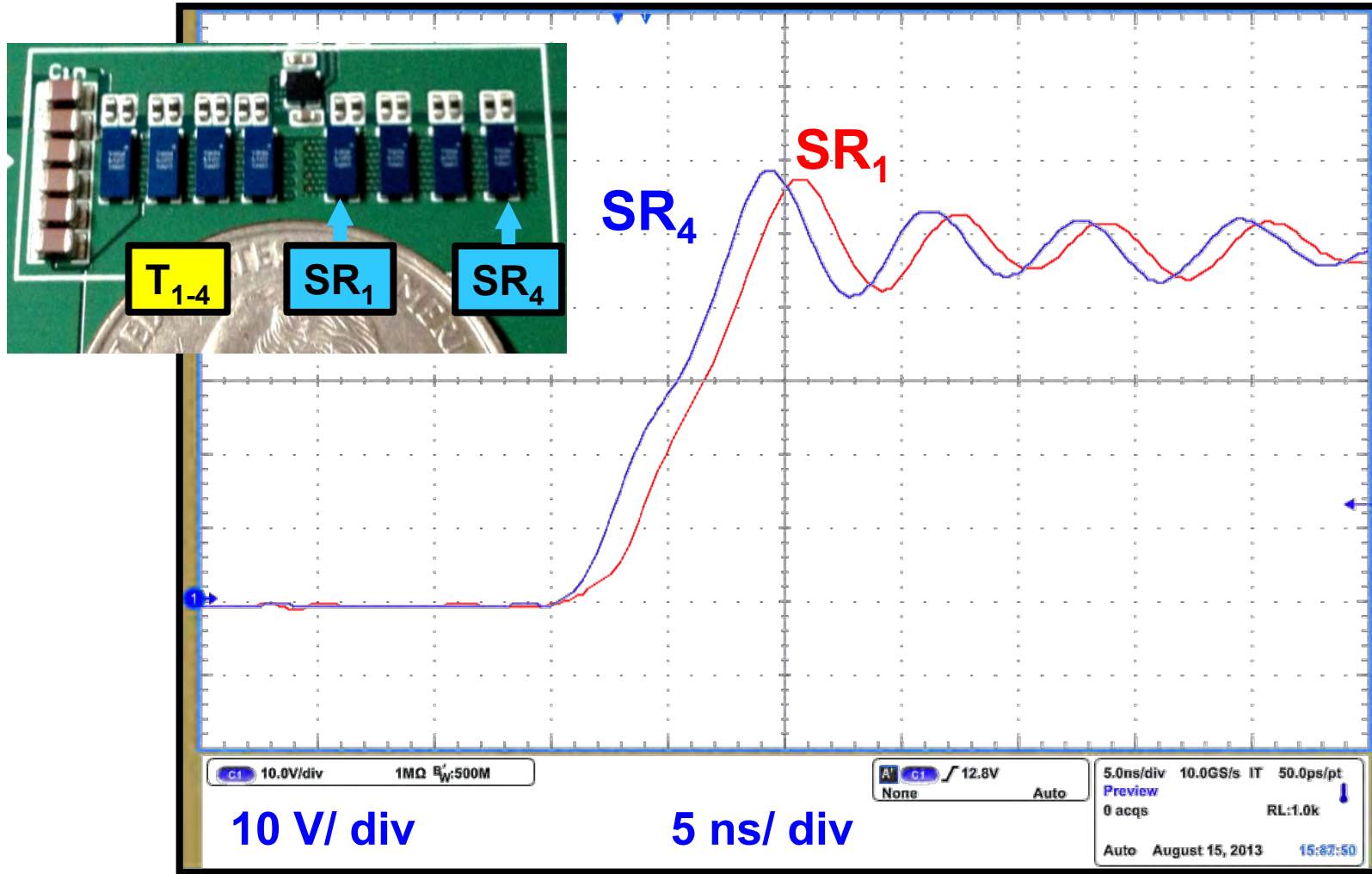
Paralleling High-Speed eGaN FETs





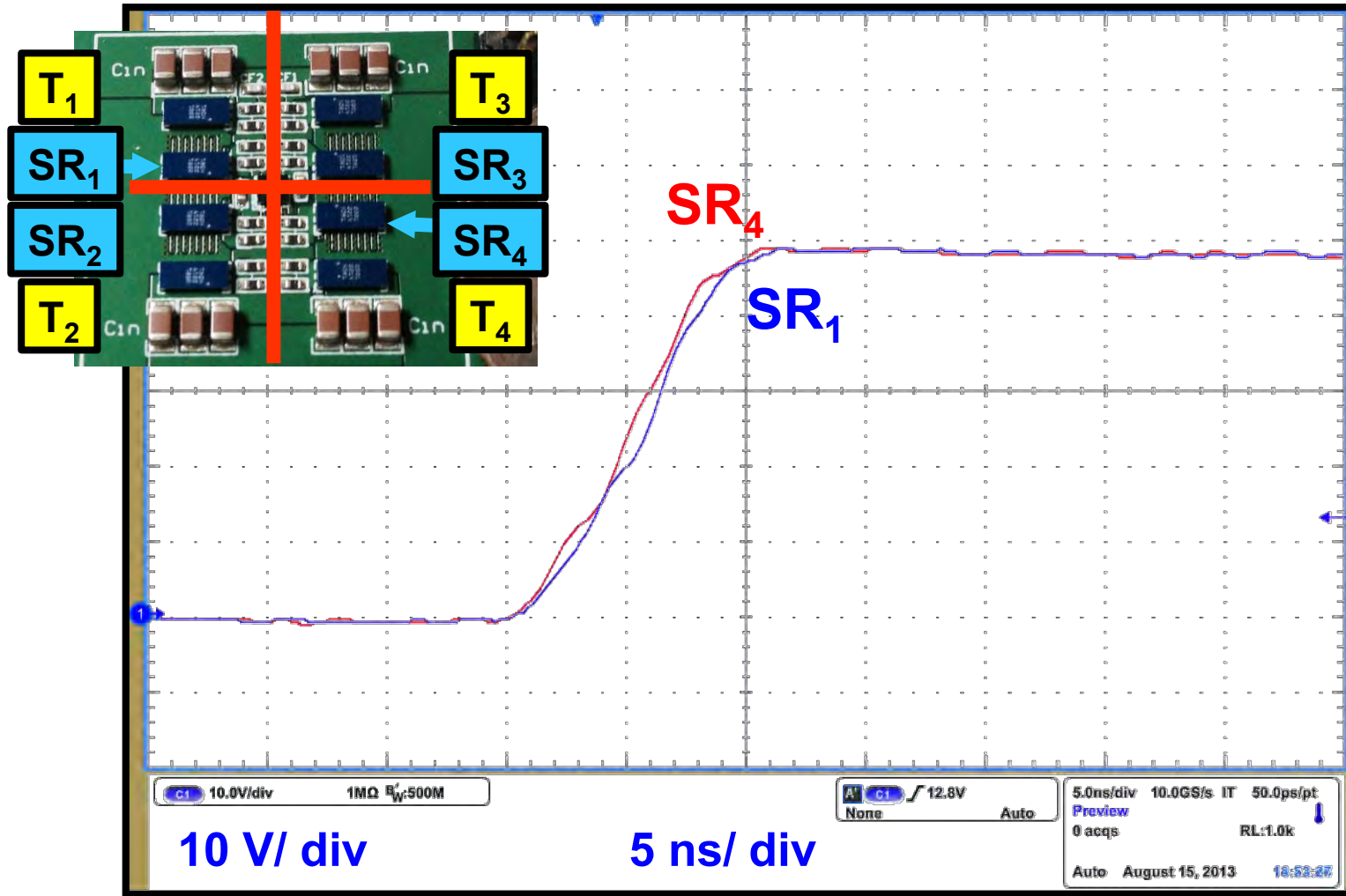


$V_{IN}=48\text{ V}$ $I_{OUT}=25\text{ A}$ eGaN FET T/SR: 100 V EPC2001

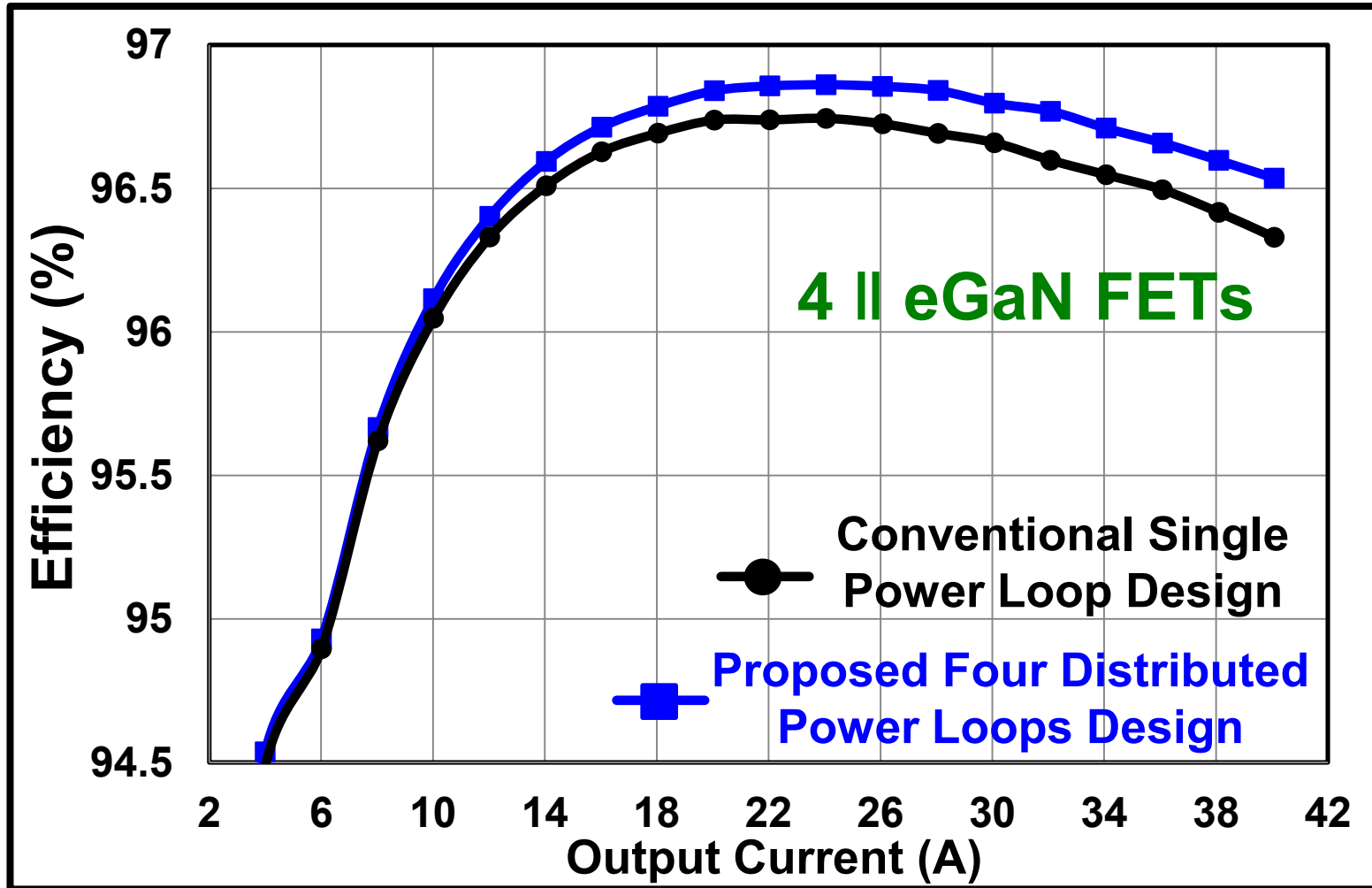


$V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $I_{OUT}=30\text{ A}$ $f_{sw}=300\text{ kHz}$ $L=3.3\ \mu\text{H}$ GaN FET T/SR: 100 V EPC2001

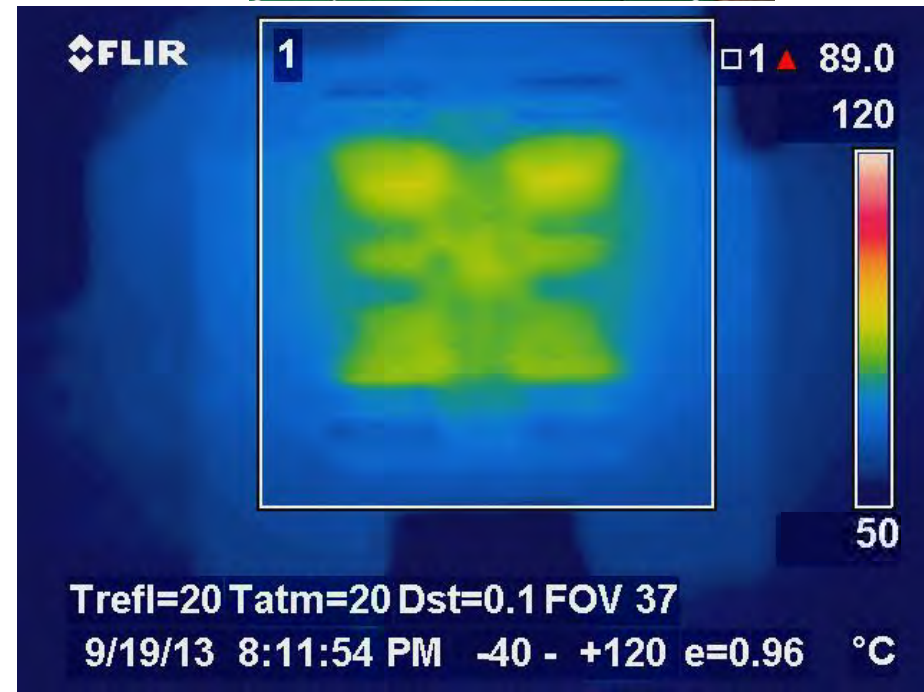
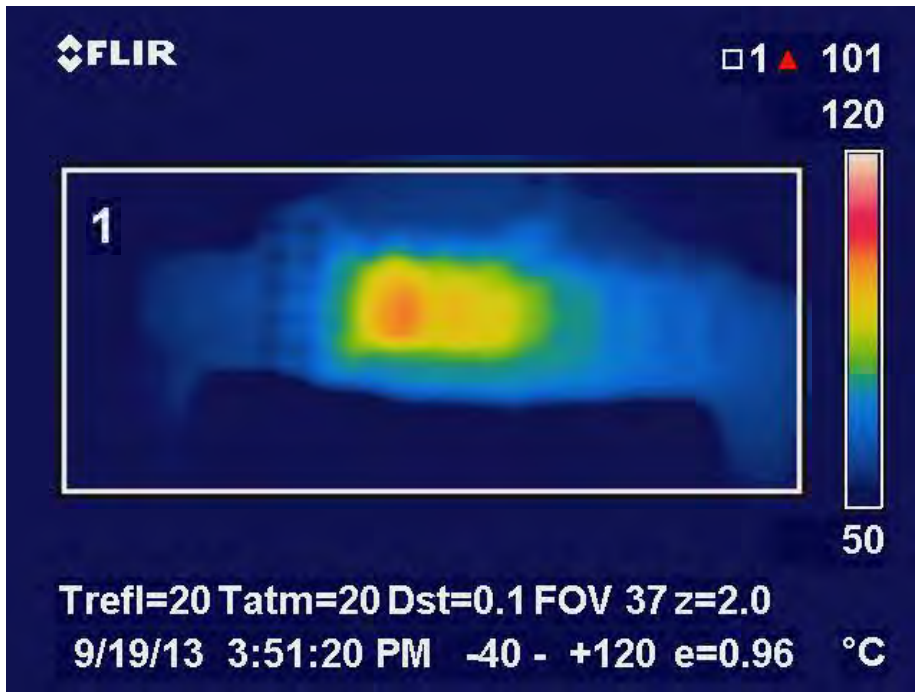
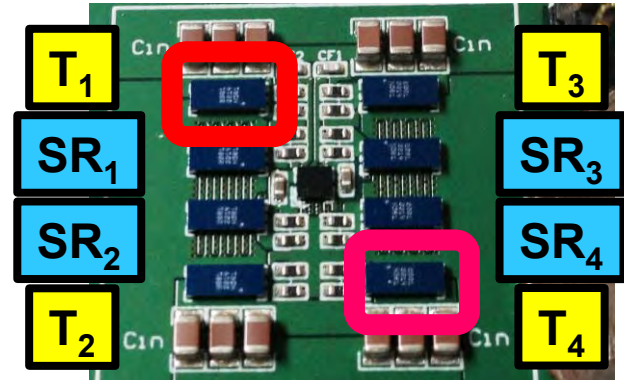
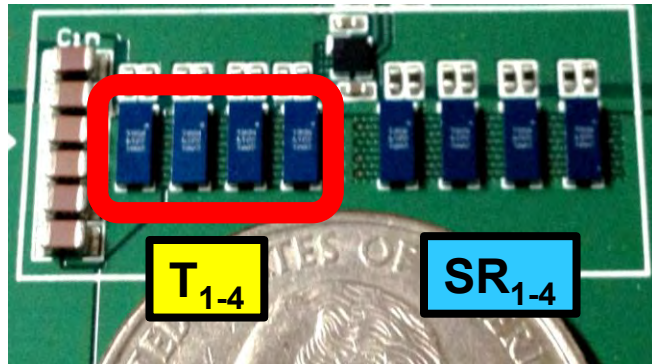
Parallel Loop Optimal Layout



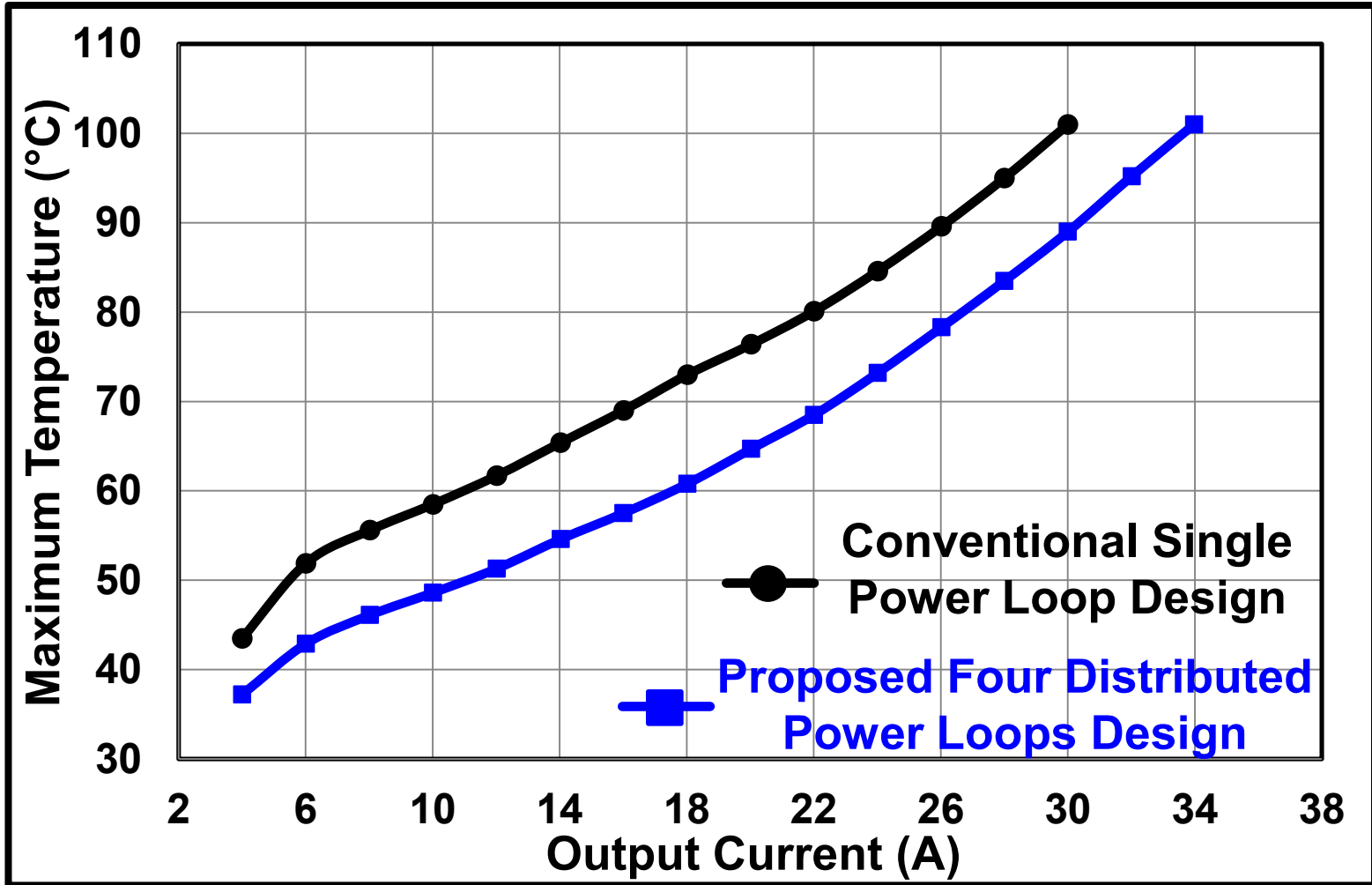
$V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $I_{OUT}=30\text{ A}$ $f_{sw}=300\text{ kHz}$ $L=3.3\ \mu\text{H}$ GaN FET T/SR: 100 V EPC2001



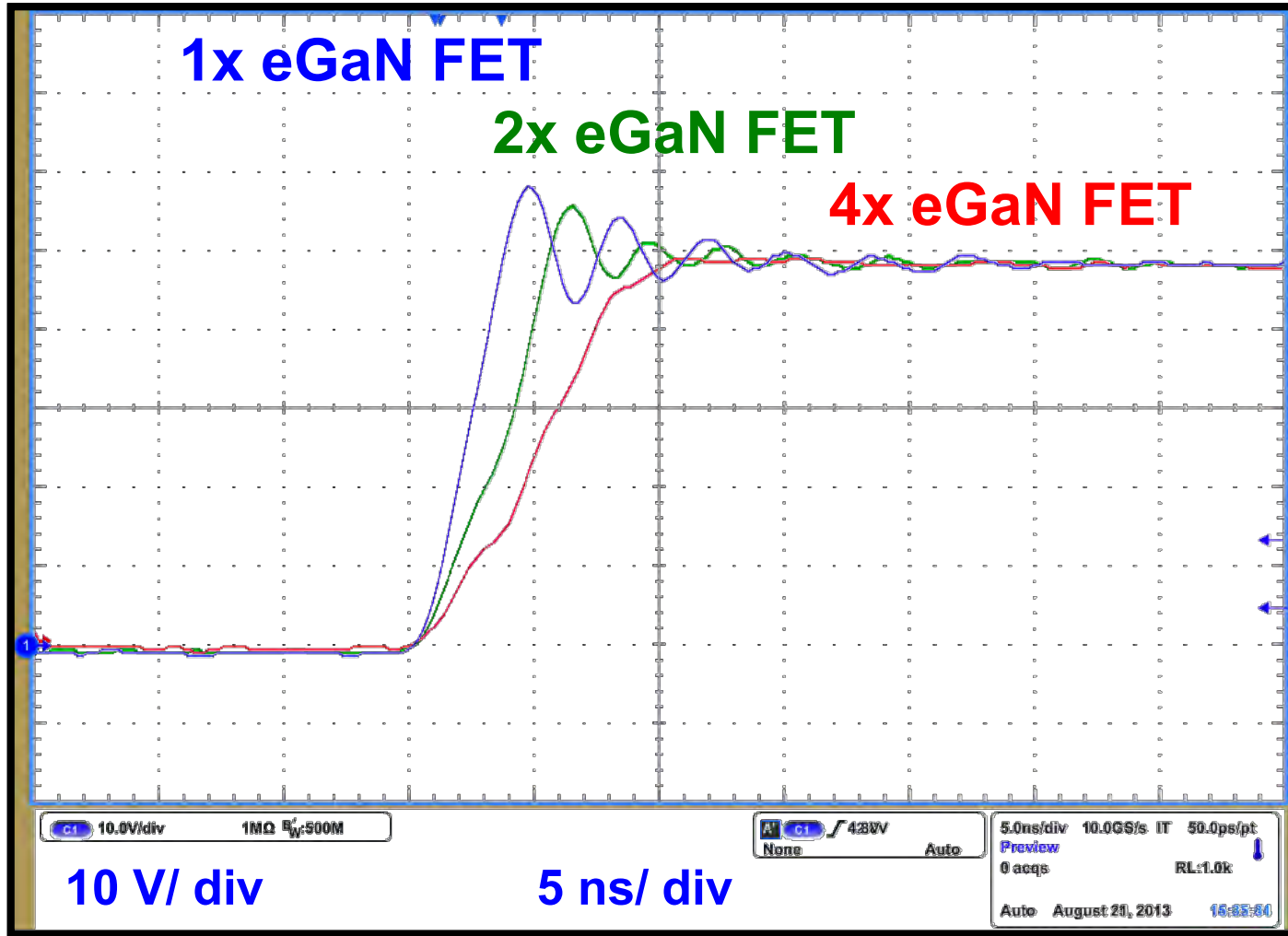
$V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $f_{sw}=300\text{ kHz}$ $L=3.3\ \mu\text{H}$ GaN FET T/SR: 4x100 V EPC2001
4 Layer 2 oz PCB



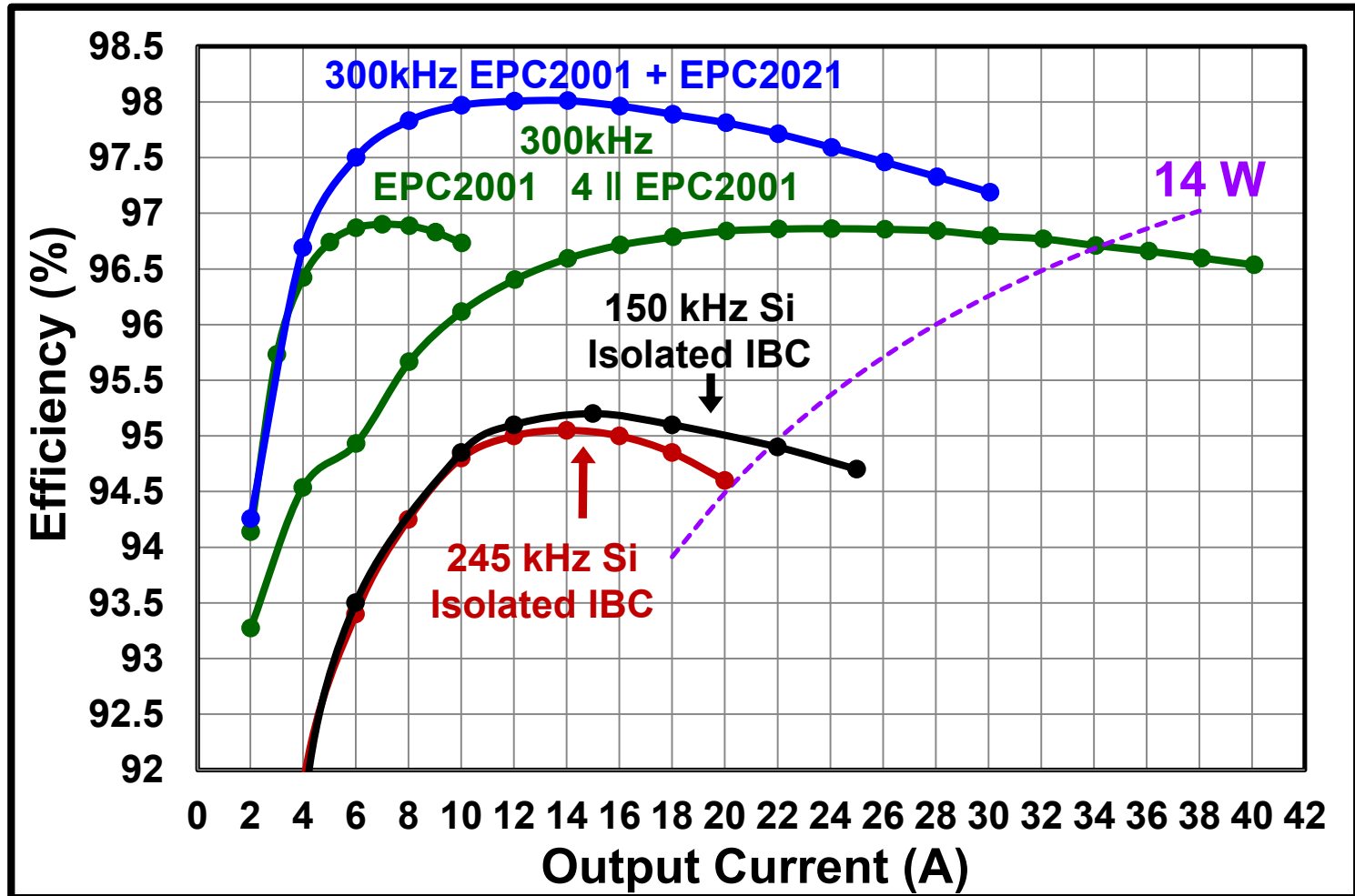
$V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $I_{OUT}=30\text{ A}$ $f_{sw}=300\text{ kHz}$ $L=3.3\text{ }\mu\text{H}$ GaN FET T/SR: 100 V EPC2001



$V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $f_{sw}=300\text{ kHz}$ $L=3.3\ \mu\text{H}$ GaN FET T/SR: 100 V EPC2001
 Fan Speed 200 LFM 4 Layer 2 oz PCB

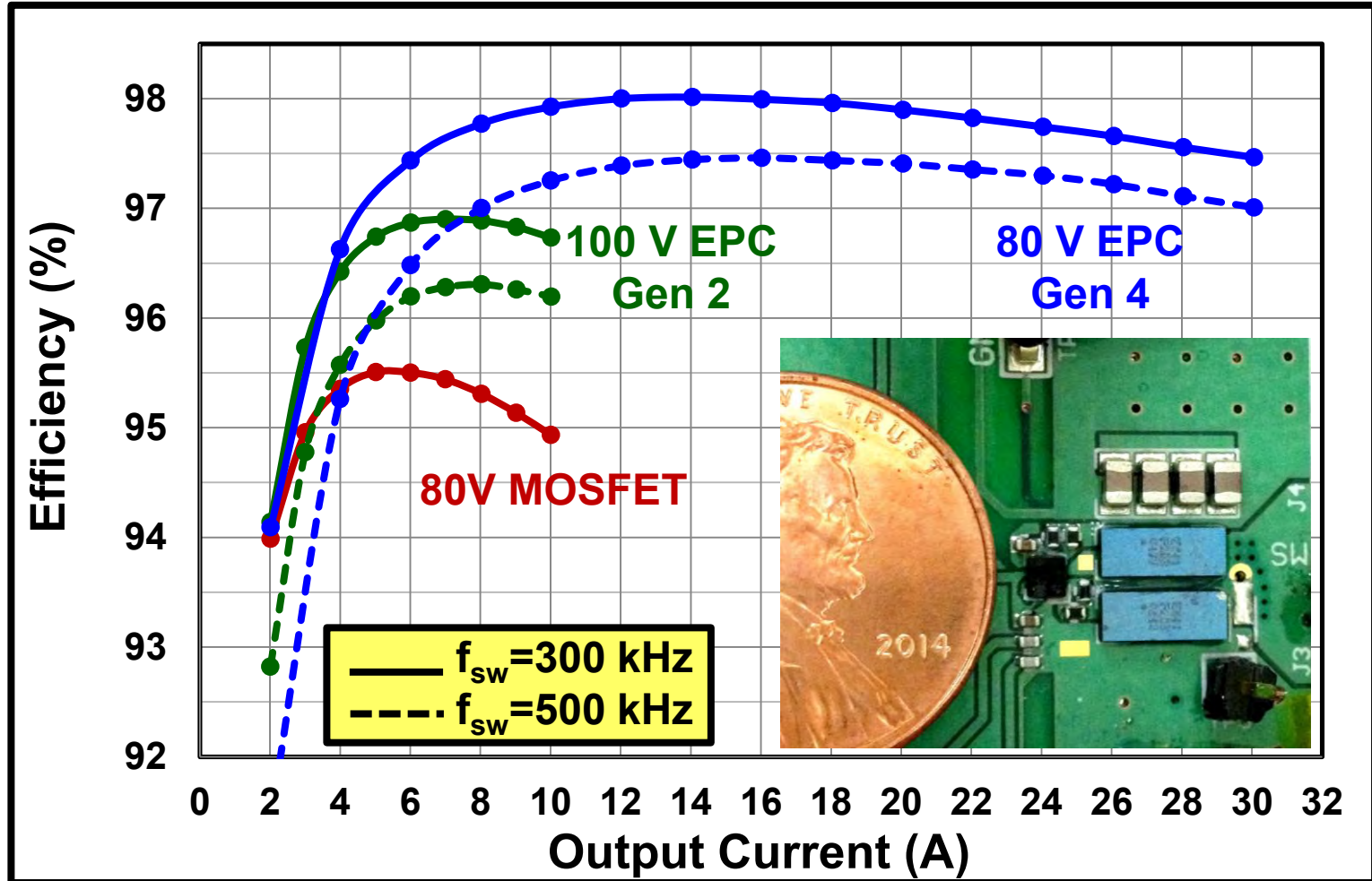


$V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $I_{OUT}=30\text{ A}$ / number of devices $f_{sw}=300\text{ kHz}$ GaN FET T/SR: 100 V EPC2001

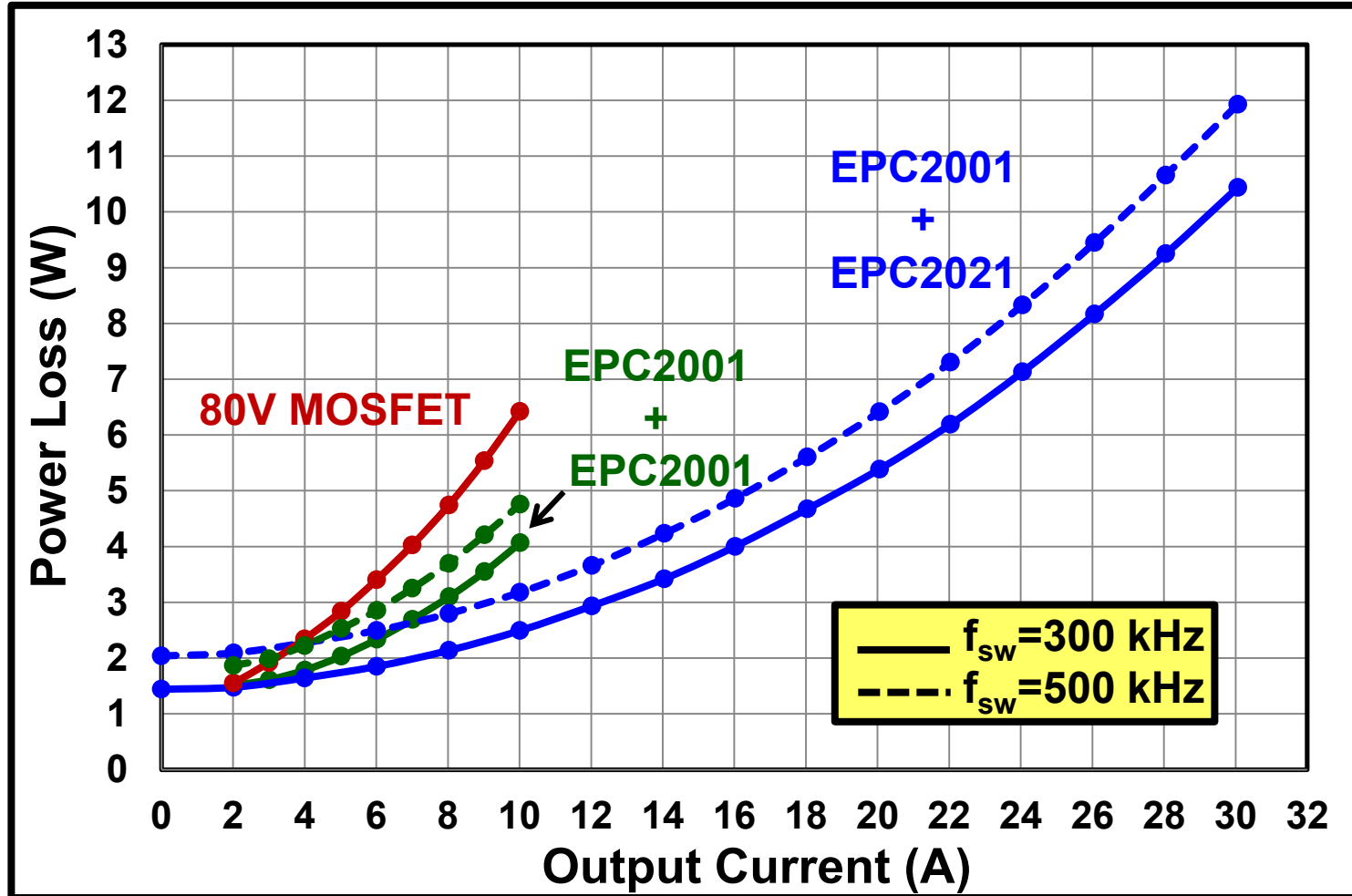


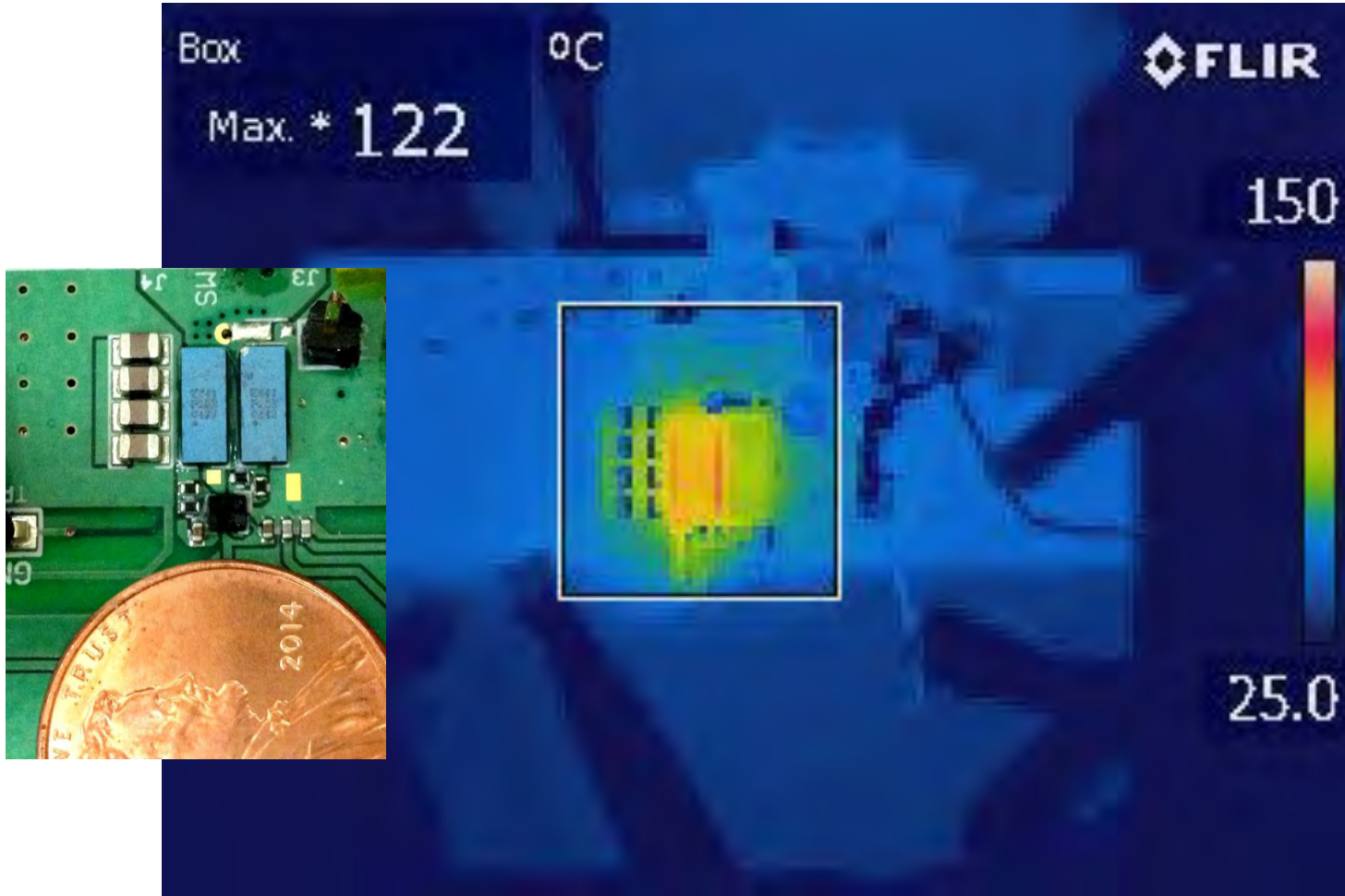
$V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ Fully Regulated IBC

Higher Current Devices



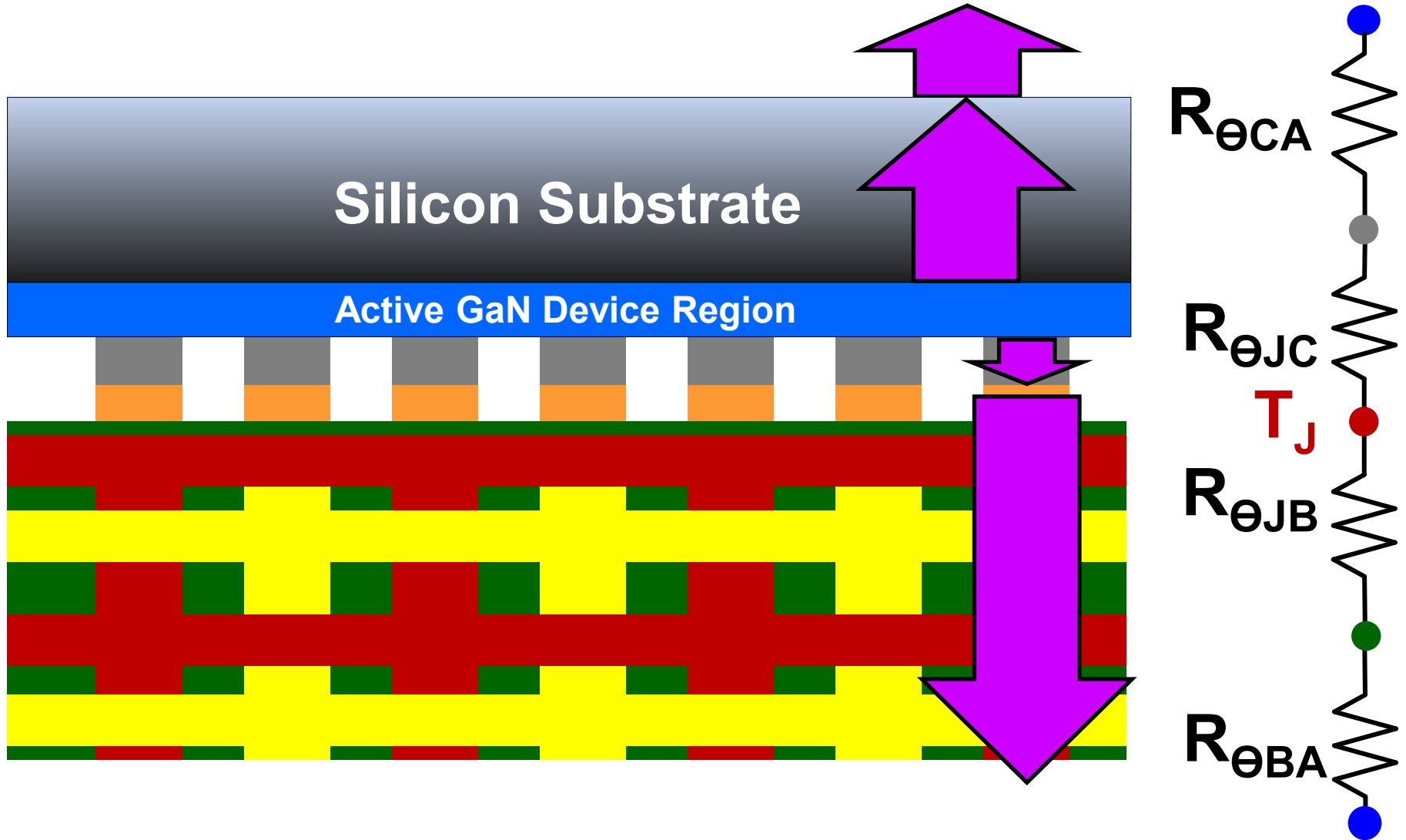
$V_{IN} = 48 \text{ V}$ $V_{OUT} = 12 \text{ V}$



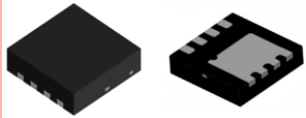


Fan Speed=200 LFM $f_{sw}=300$ kHz $V_{IN}=48$ V $V_{OUT}=12$ V $I_{OUT}=30$ A

Thermal



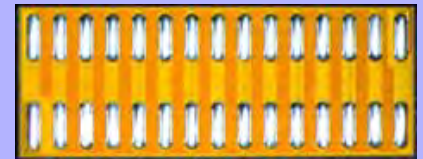
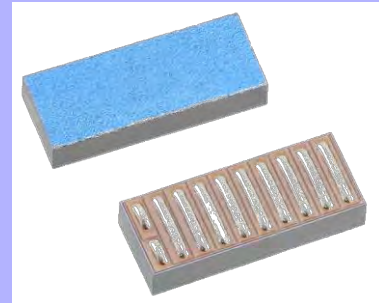
Single Sided Cooling



Double Sided Cooling



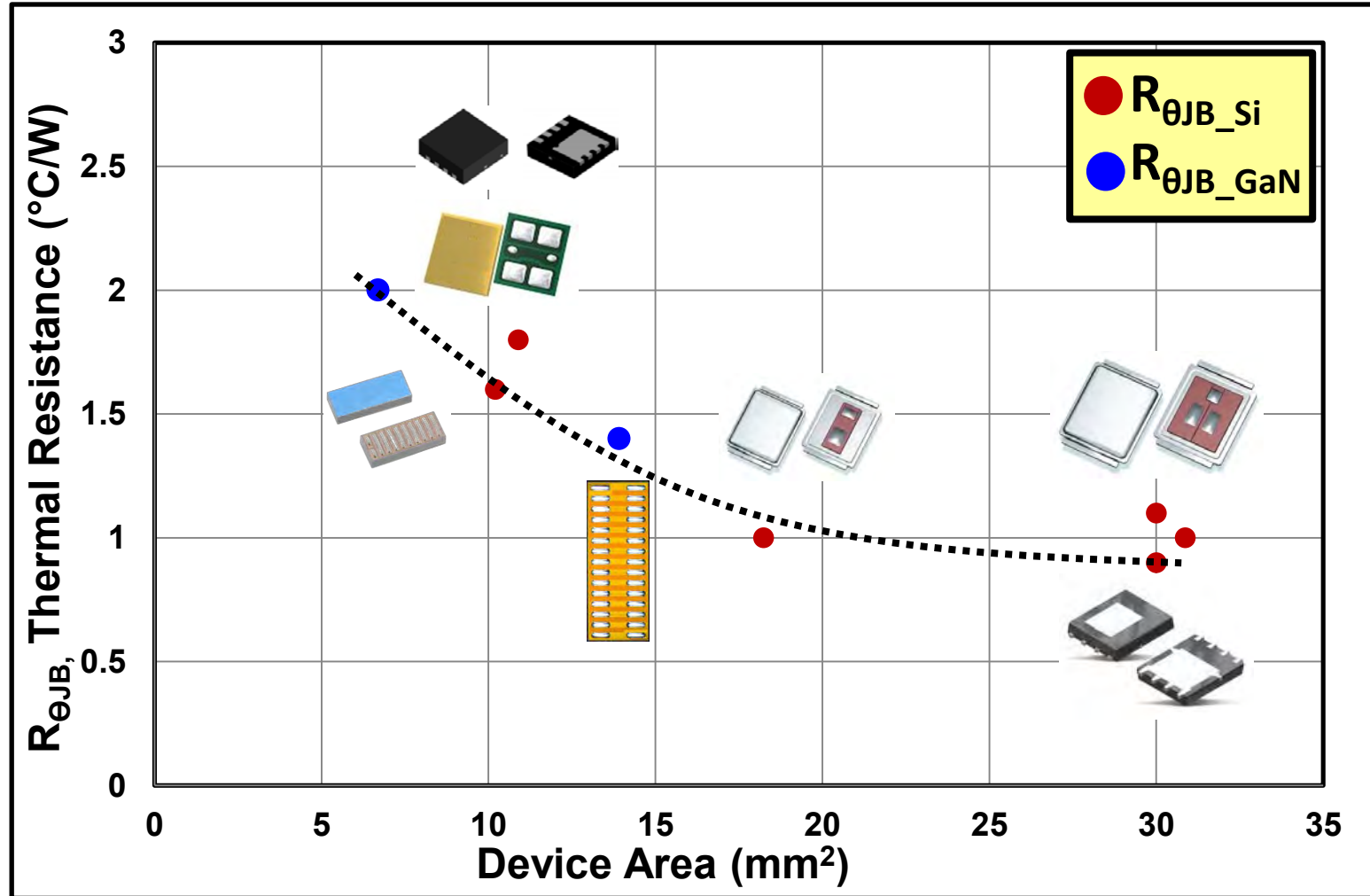
Double Sided Cooling

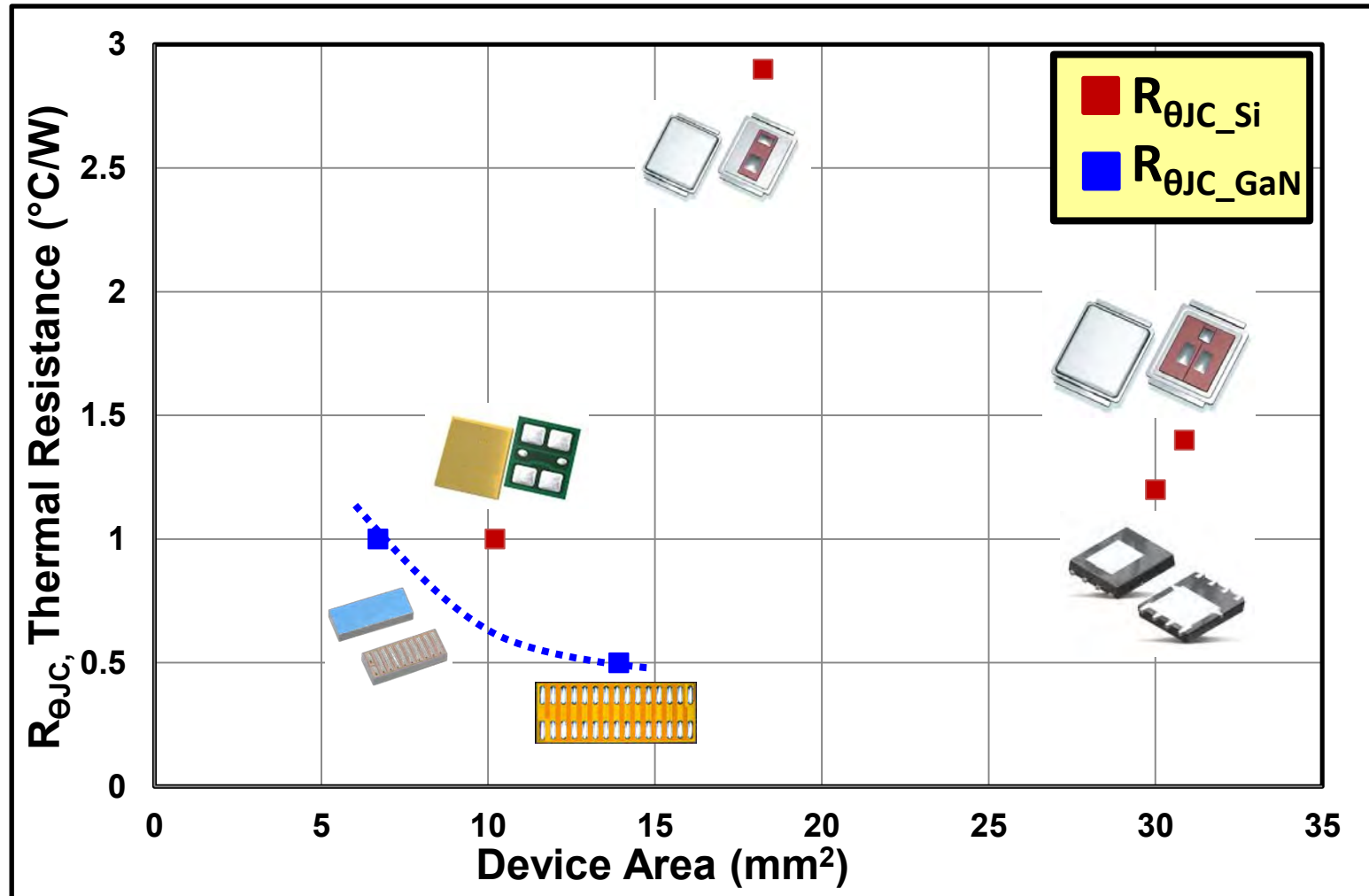


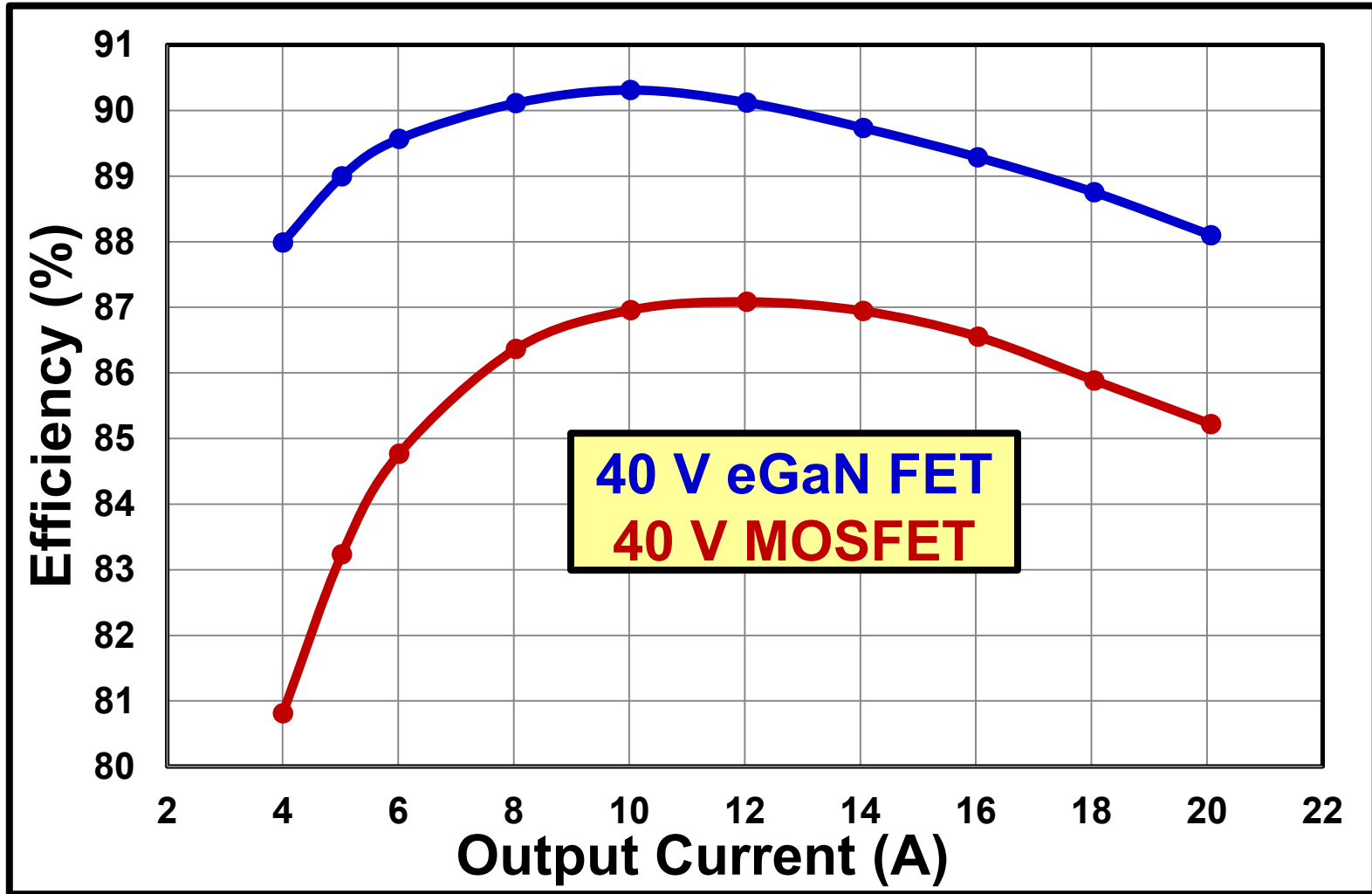
$$R_{\theta JB} \downarrow \ll R_{\theta JC} \uparrow$$

$$R_{\theta JB} \downarrow \quad R_{\theta JC} \downarrow$$

$$R_{\theta JB} \downarrow \quad R_{\theta JC} \downarrow$$

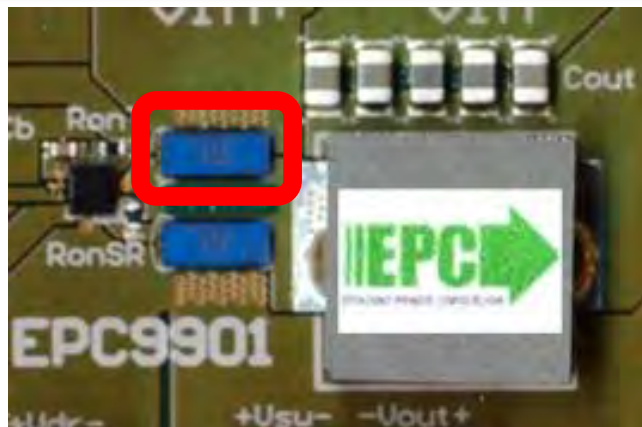




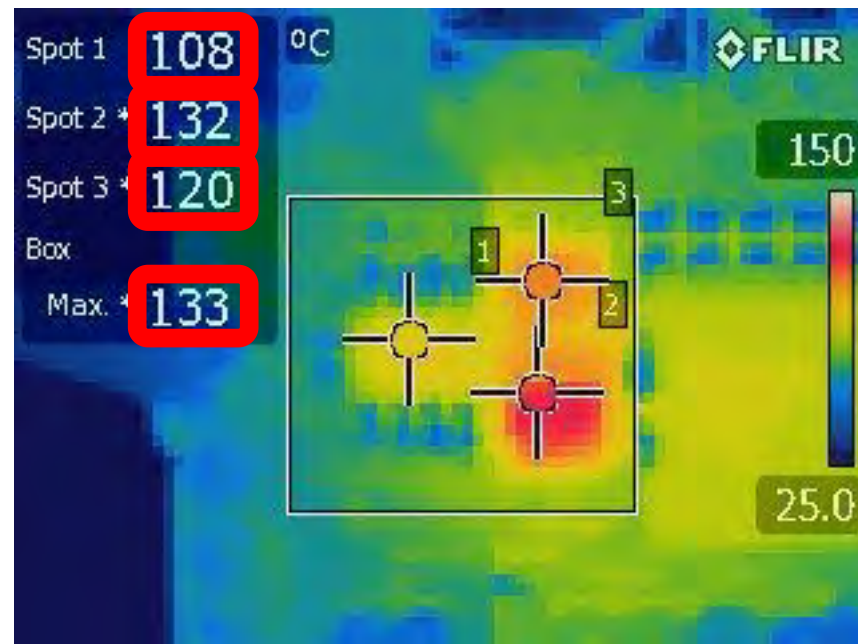
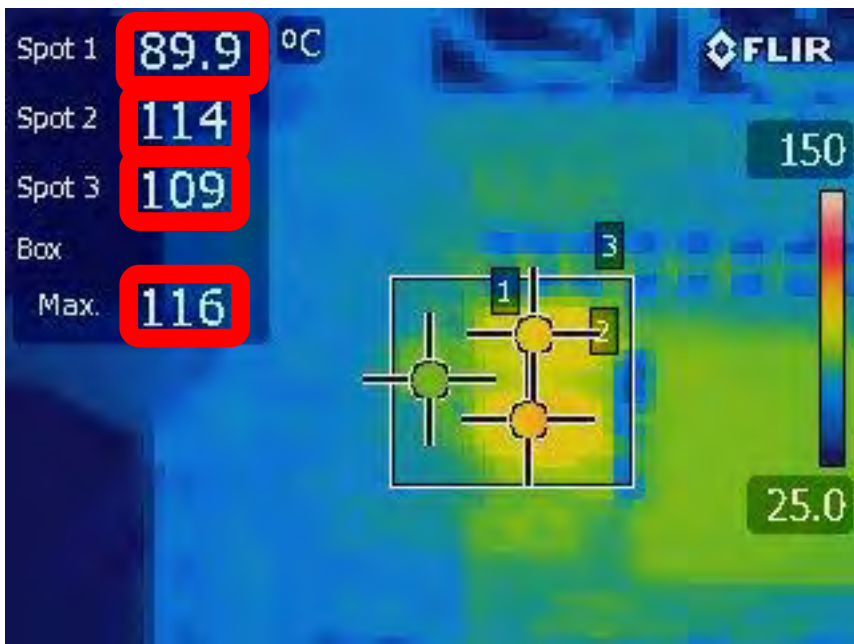


$V_{IN}=12\text{ V}$, $V_{OUT}=1.2\text{ V}$, $f_{sw}=1\text{ MHz}$, $L=300\text{ nH}$

Thermal Comparison

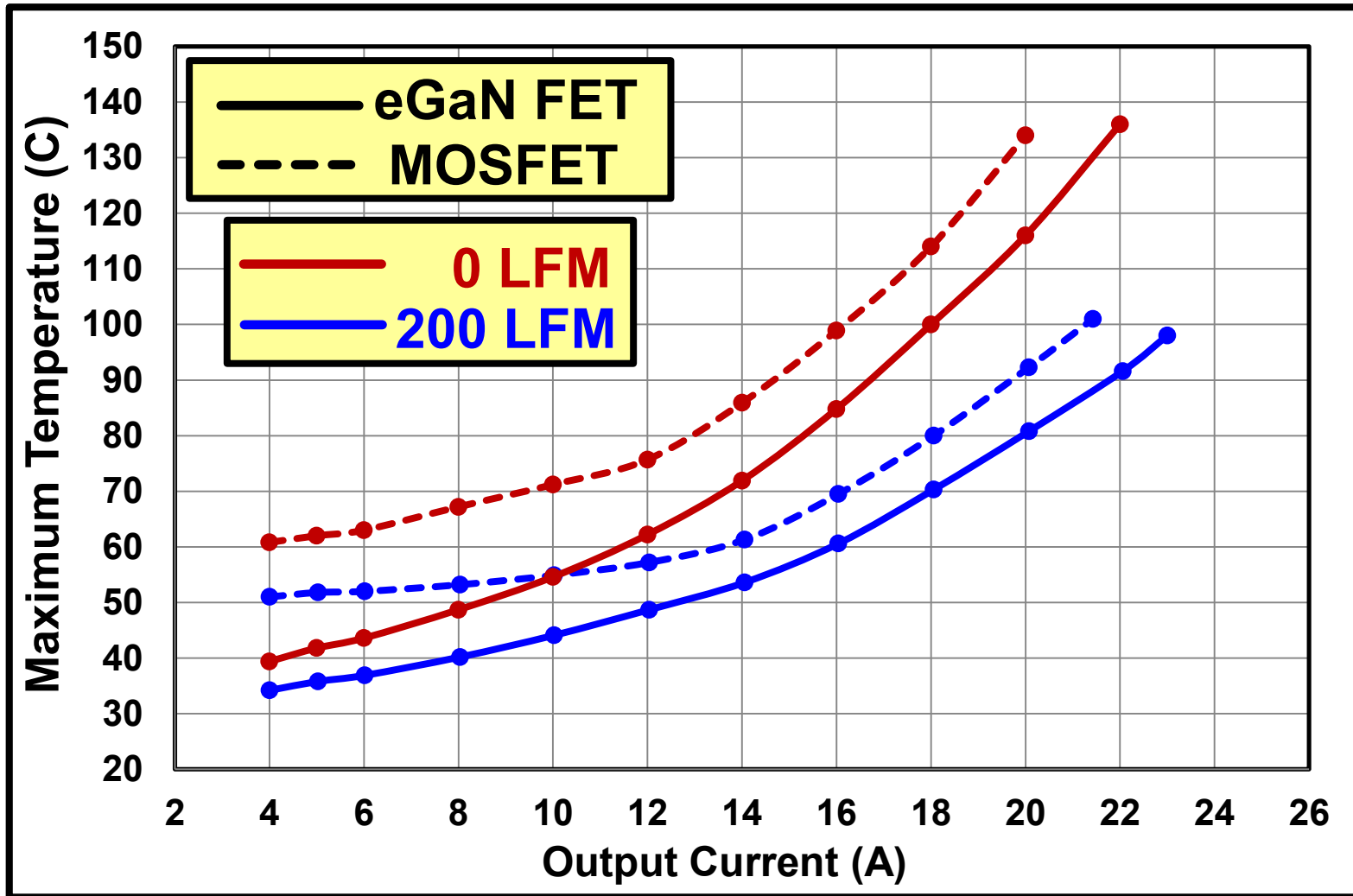


**GaN is
38% Smaller
13% Cooler**

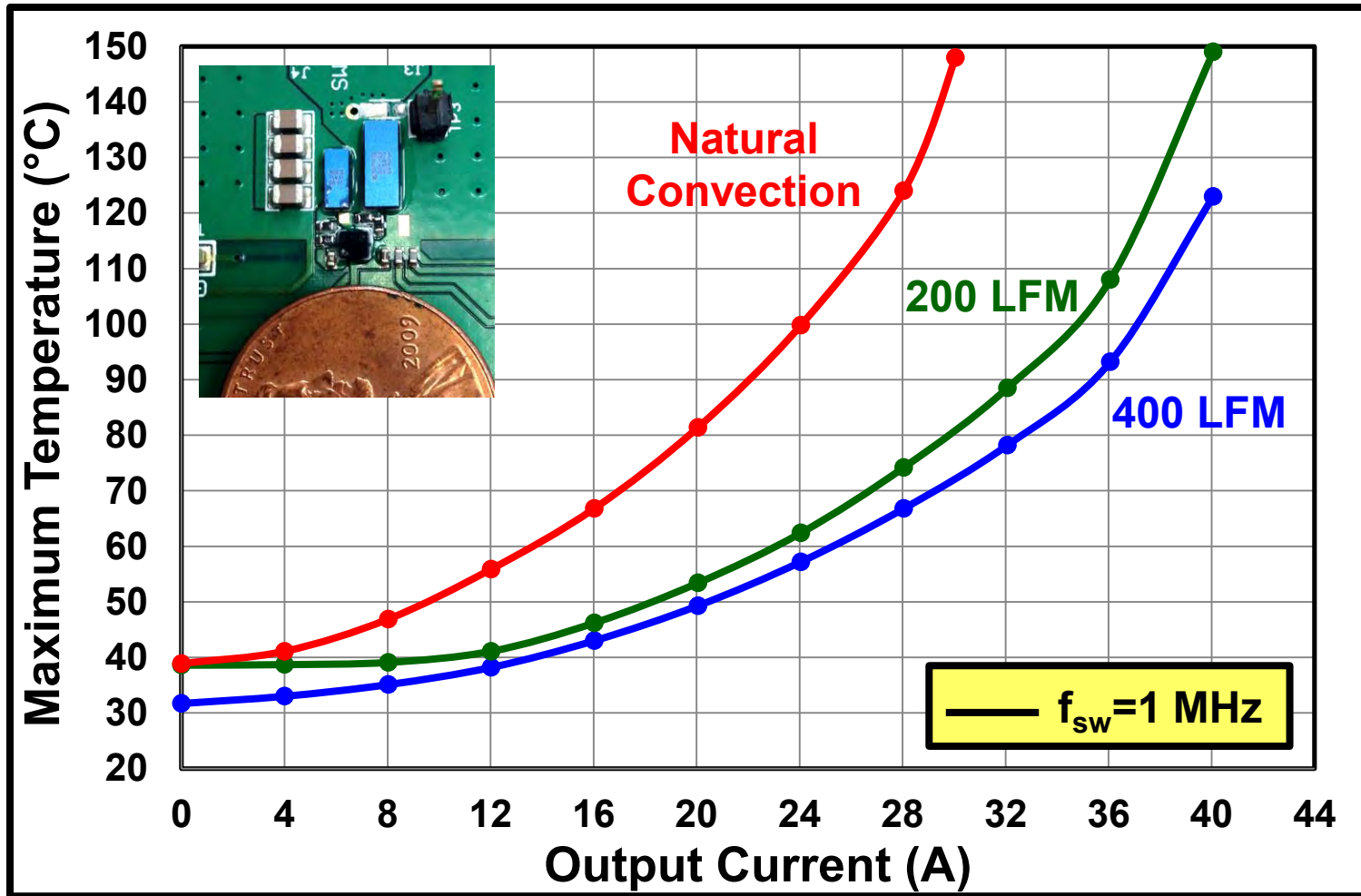


$V_{IN}=12\text{ V}$, $V_{OUT}=1.2\text{ V}$, $I_{OUT}=20\text{ A}$, $f_{sw}=1\text{ MHz}$, $L=300\text{ nH}$

Thermal Comparison



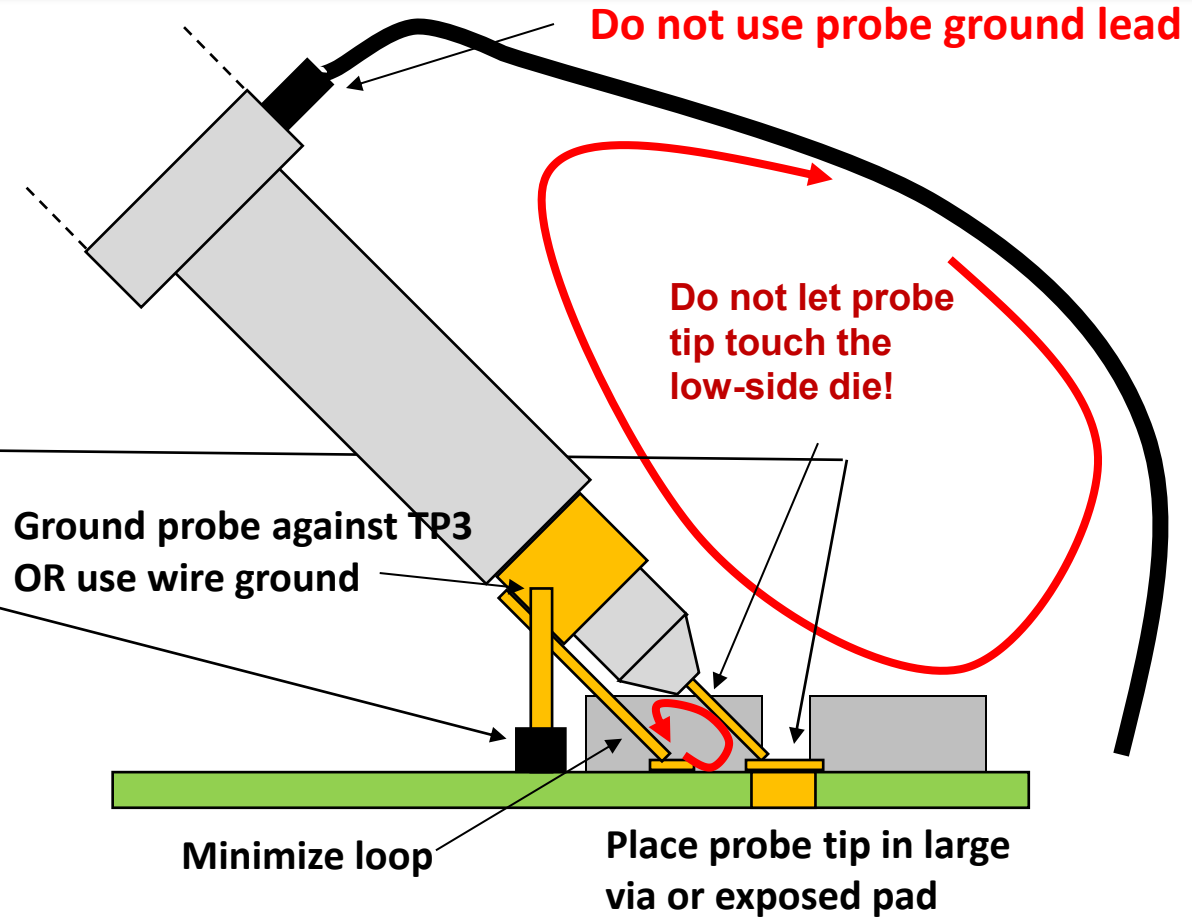
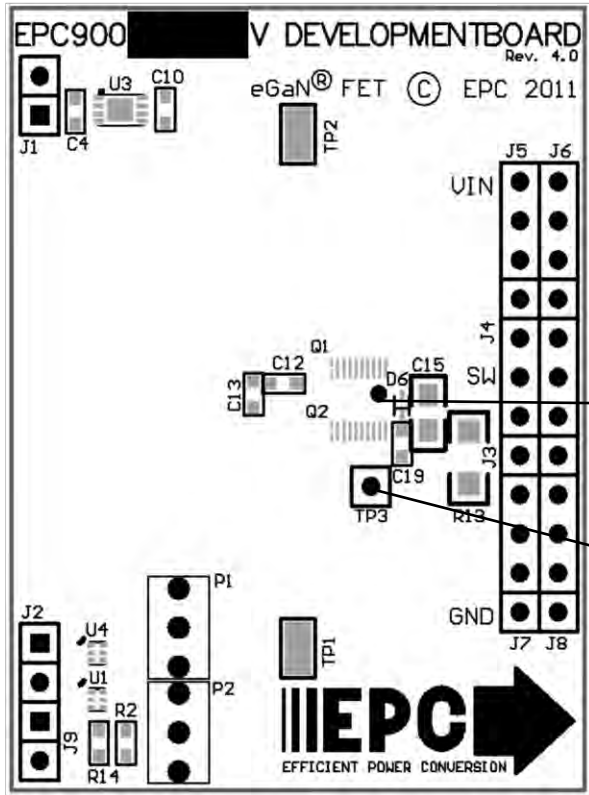
$V_{IN}=12\text{ V}$, $V_{OUT}=1.2\text{ V}$, $f_{sw}=1\text{ MHz}$, $L=300\text{ nH}$



$V_{IN} = 12$ V $V_{OUT} = 1.2$ V

Measurement

Voltage Measurement



Tektronix PCB Jack



Yokogawa Probe



Hand-made Probe Adapter

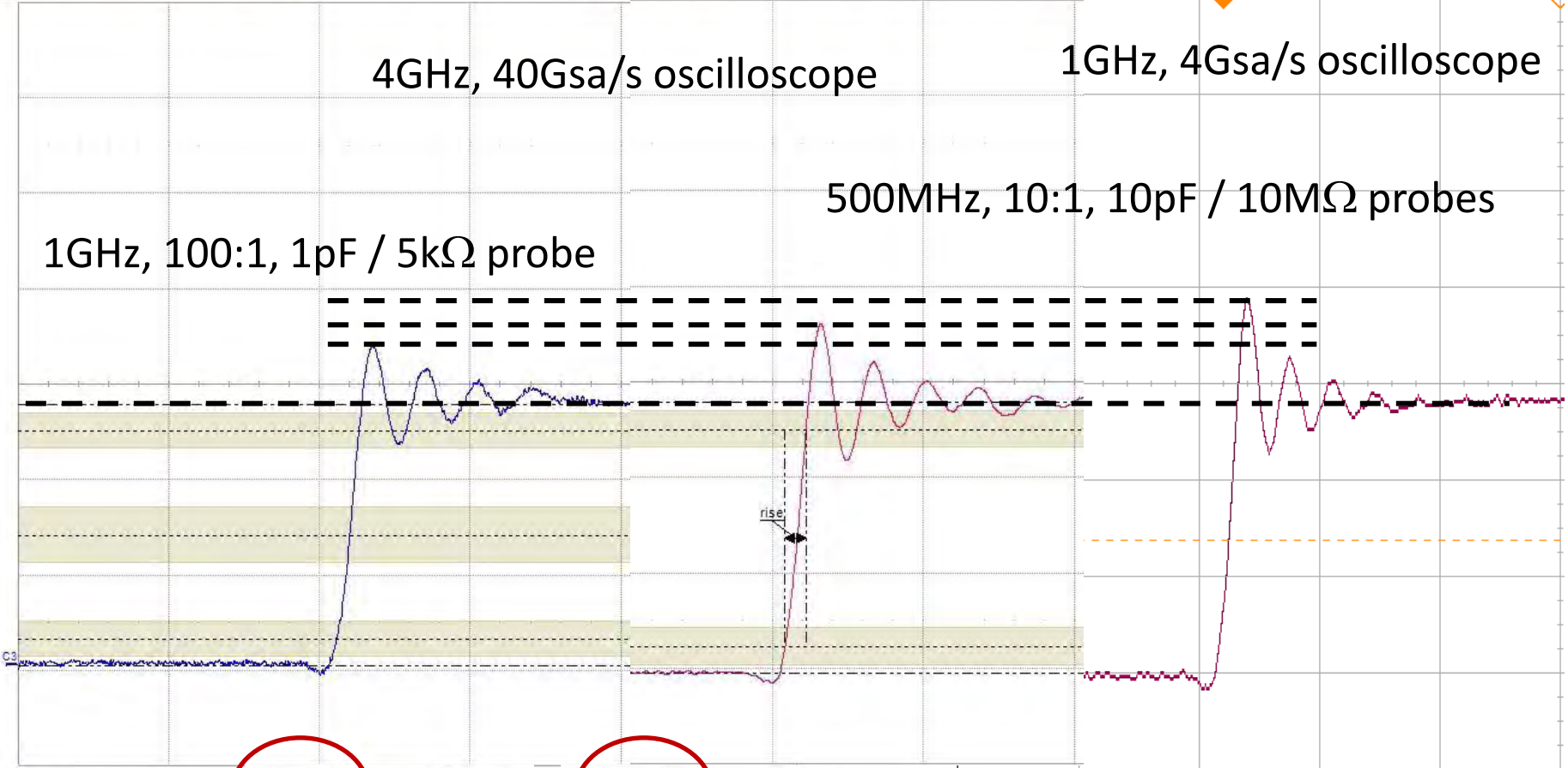
File Vertical Timebase Trigger Display Cursors Measure Math Analysis Use Trigger Display Cursors Measure Math Analysis 4 10.0V/ 28.00ns 10.00ns/

4GHz, 40Gsa/s oscilloscope

1GHz, 4Gsa/s oscilloscope

500MHz, 10:1, 10pF / 10MΩ probes

1GHz, 100:1, 1pF / 5kΩ probe



Measure value status

10.0 V/div
-29.30 V

LeCroy

P3:rise(C3)
1.496 ns ✓

P4:fall(C3)
1.492 ns ✓

P5:rise(C2)
1.404 ns ✓

P6:fall(C2)
1.317 ns ✓

Rise(4): 1.4ns

Fall(4): 1.1ns

- *eGaN FETs raise the bar for power conversion performance*
- **Lower resistance per die area**
- **Better FOM's**
- **Better Packaging**
- **Improved PCB Layout Techniques**
 - **Superior In-Circuit Performance**
 - **Can parallel devices for higher current**
- **Avoid gate overshoot and long dead-times**

Design Examples

- **Resonant Bus Converter**
- **Envelope Tracking**
- **Wireless Power**
- **LiDAR**
- **Class-D Audio**

Resonant Bus Converter

- In 1989, Baliga derived a switching FOM

$$\bullet \text{BHFFOM} = \frac{1}{R_{ON,SP} \cdot C_{IN,SP}}$$

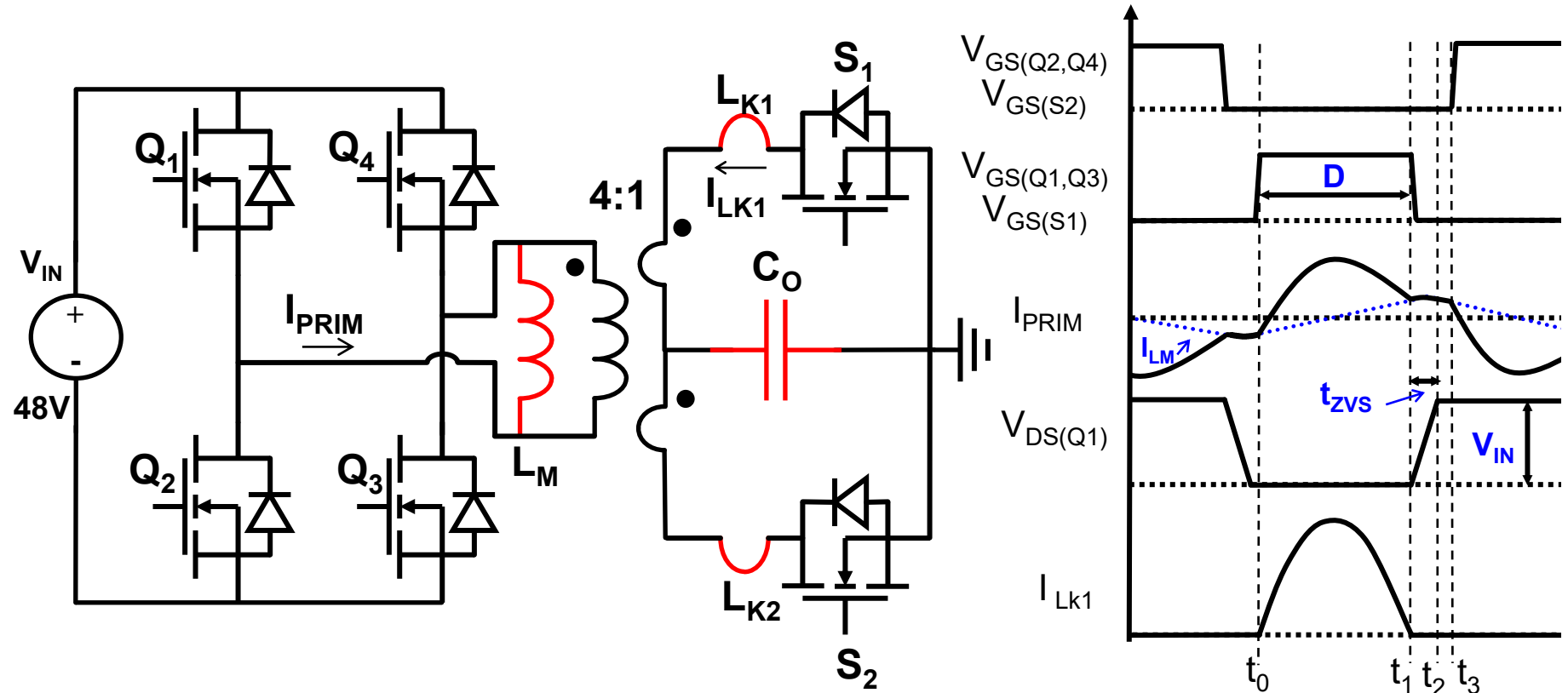
- In 1995, Kim et al proposed a new FOM

$$\bullet \text{NHFFOM} = \frac{1}{R_{ON,SP} \cdot C_{OSS,SP}}$$

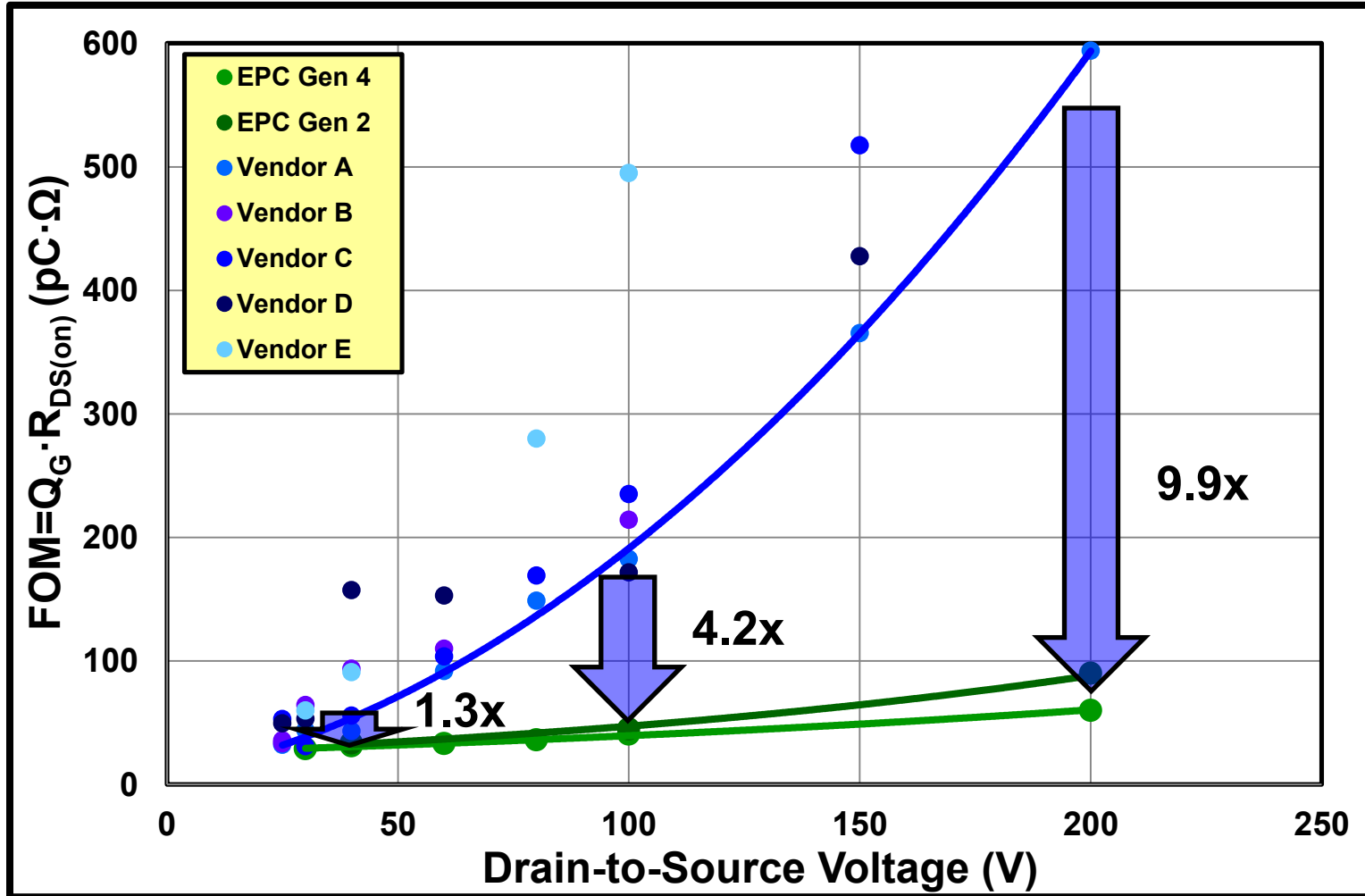
- In 2004, Huang proposed a new FOM

$$\bullet \text{HDFOM} = \sqrt{R_{ON,SP} \cdot Q_{GD,SP}}$$

High Frequency DC/DC Transformer

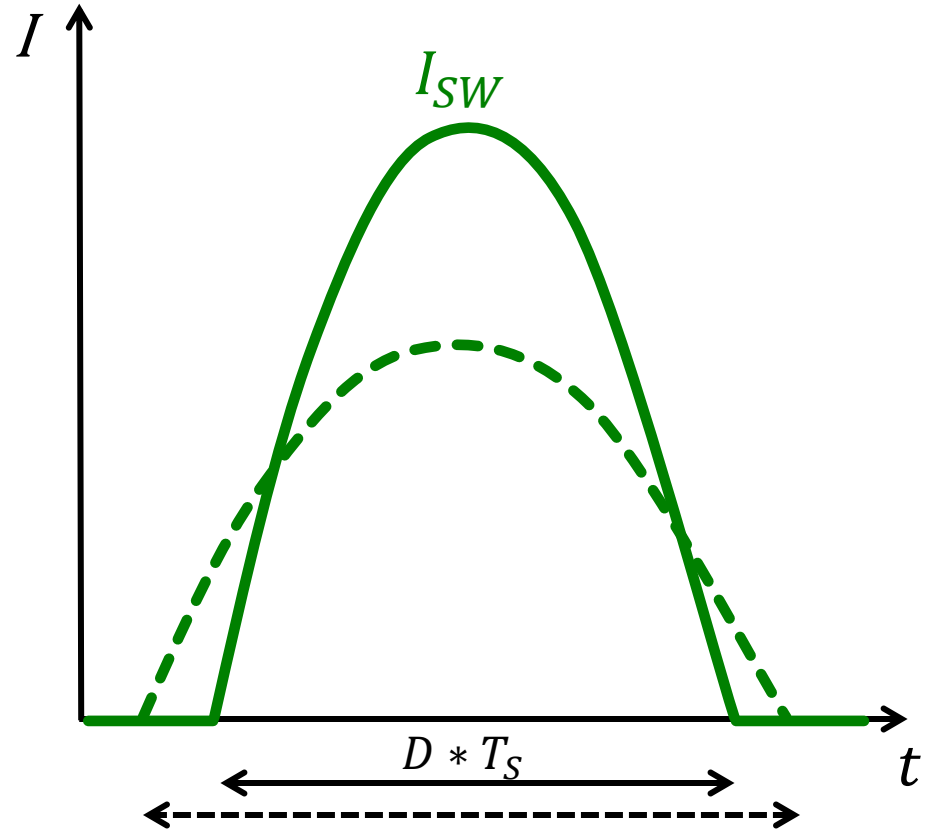
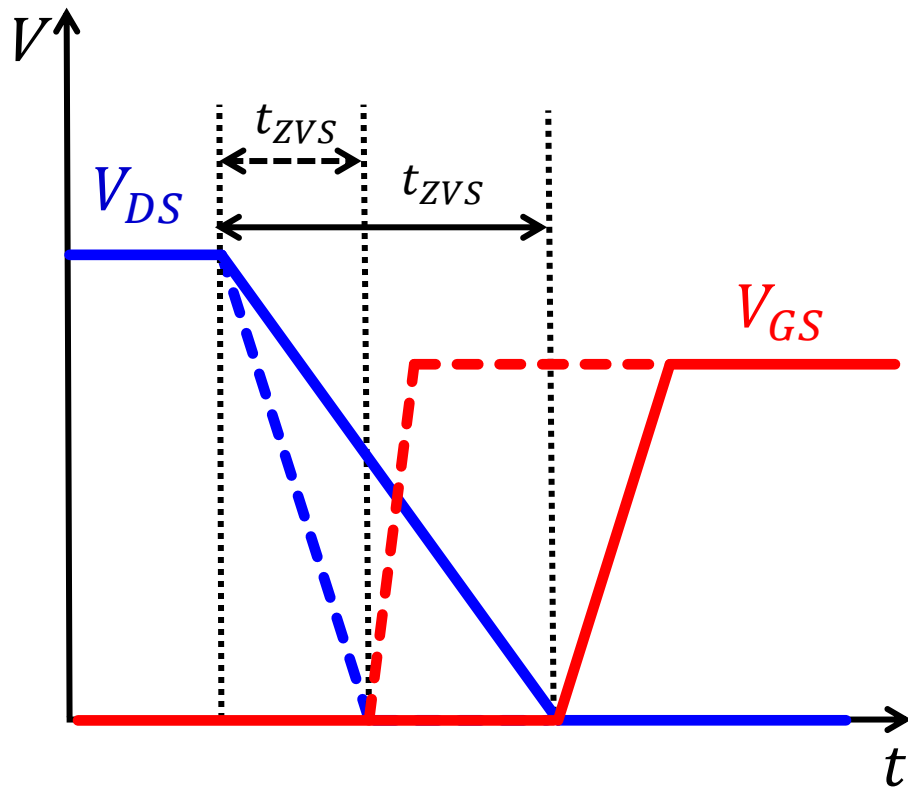


Ref: Y. Ren, M. Xu, J. Sun, and F. C. Lee, "A family of high power density unregulated bus converters," IEEE Trans. Power Electron., vol. 20, no. 5, pp. 1045–1054, Sep. 2005.

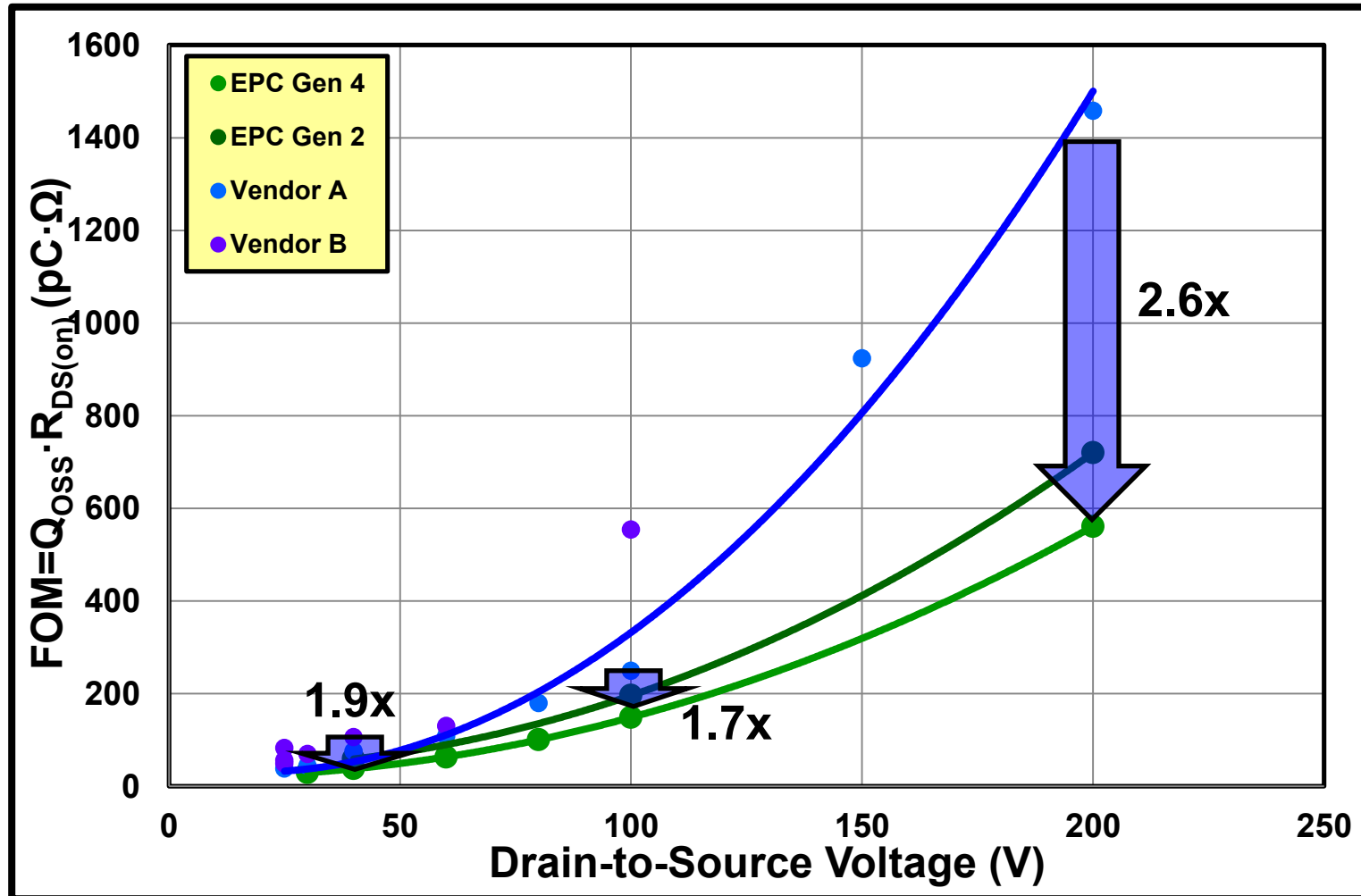


$Q_{oss} \downarrow$ $t_{zvs} \downarrow$

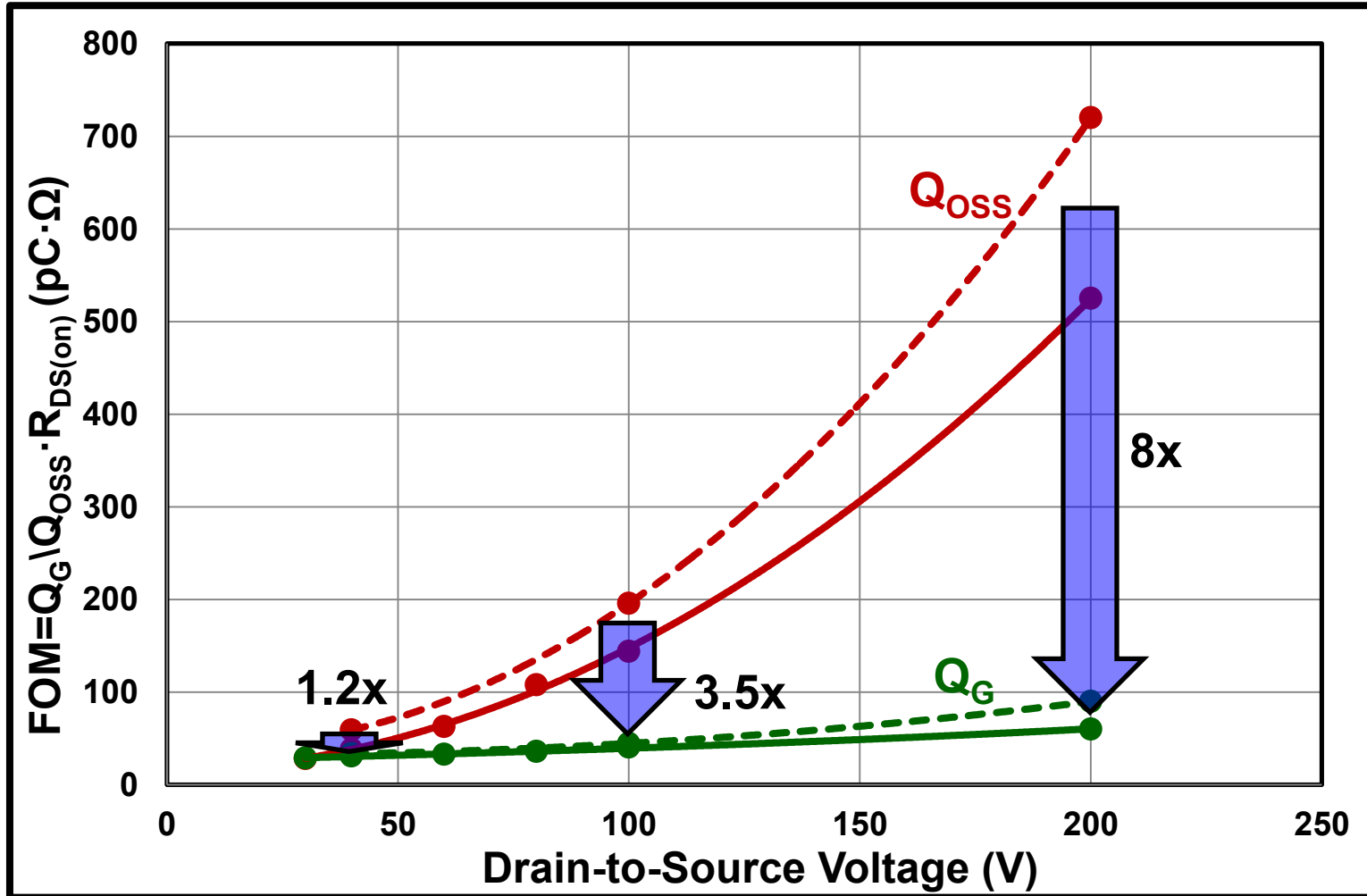
$I_{RMS} \downarrow$ $P_{CON} \downarrow$



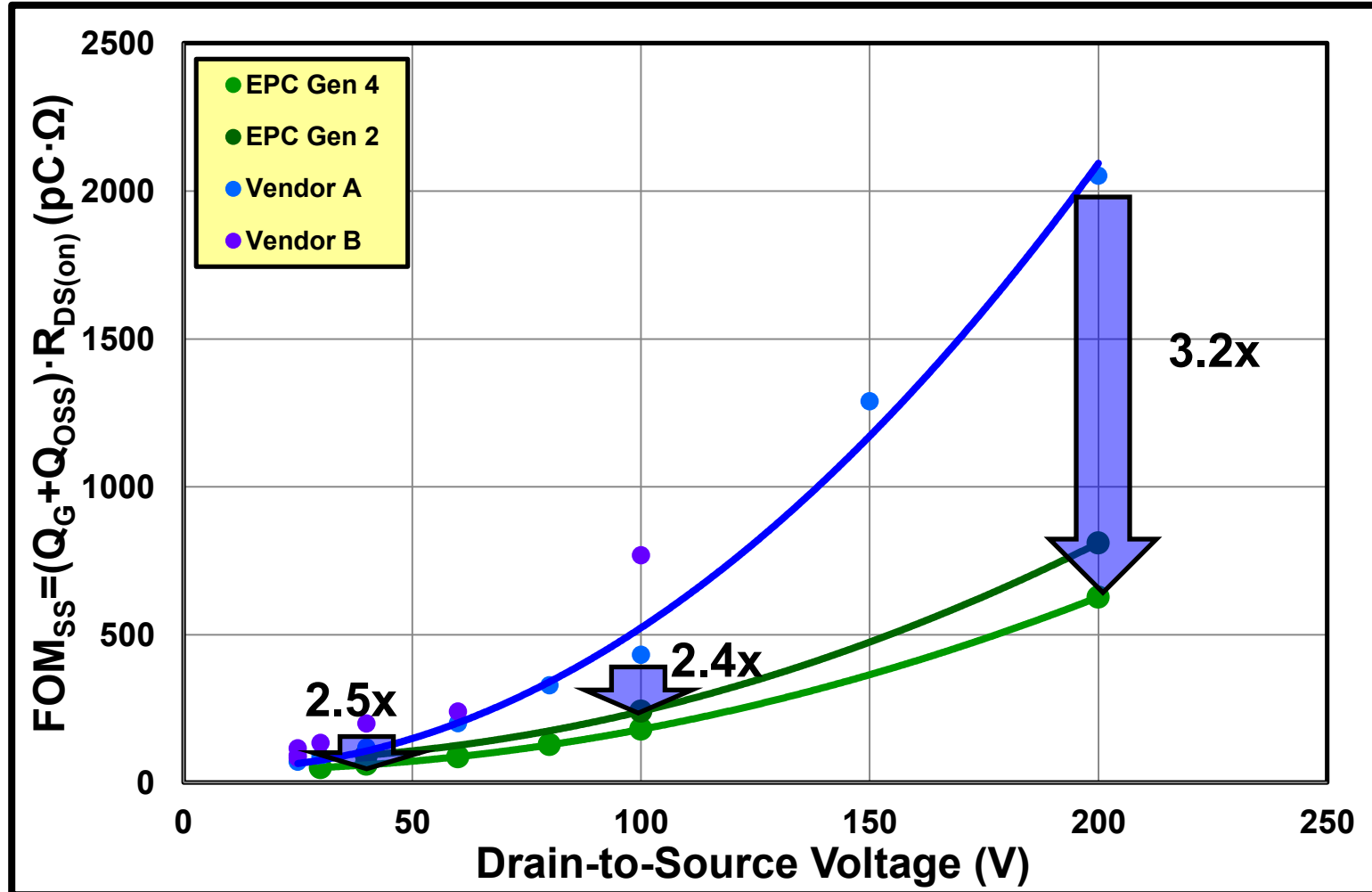
Output Charge FOM



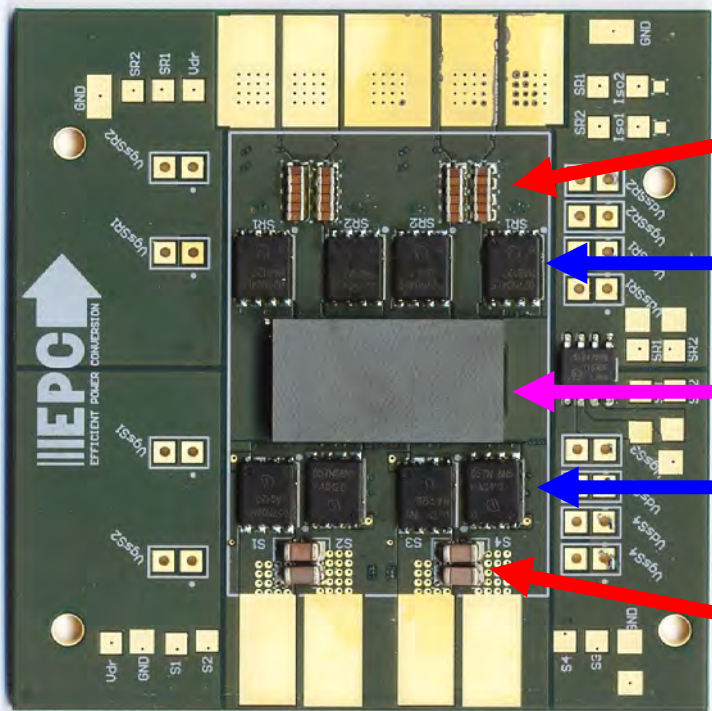
$V_{DS} = 0.5 \cdot V_{DSS}$



$$FOM_{SS} = (Q_{oss} + Q_g) \cdot R_{DS(on)}$$



$$FOM_{SS} = (Q_{OSS} + Q_G) \cdot R_{DS(on)}$$



MOSFET

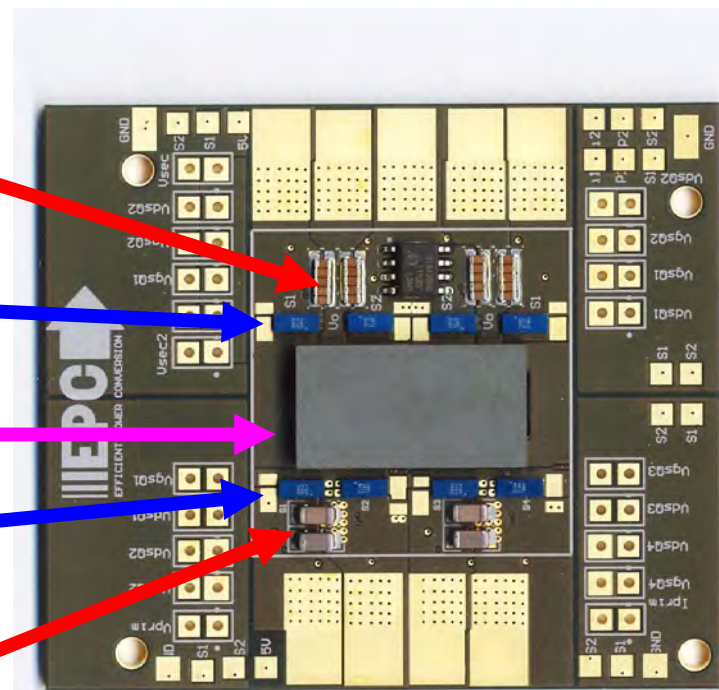
Resonant Capacitors

Secondary Devices

Transformer

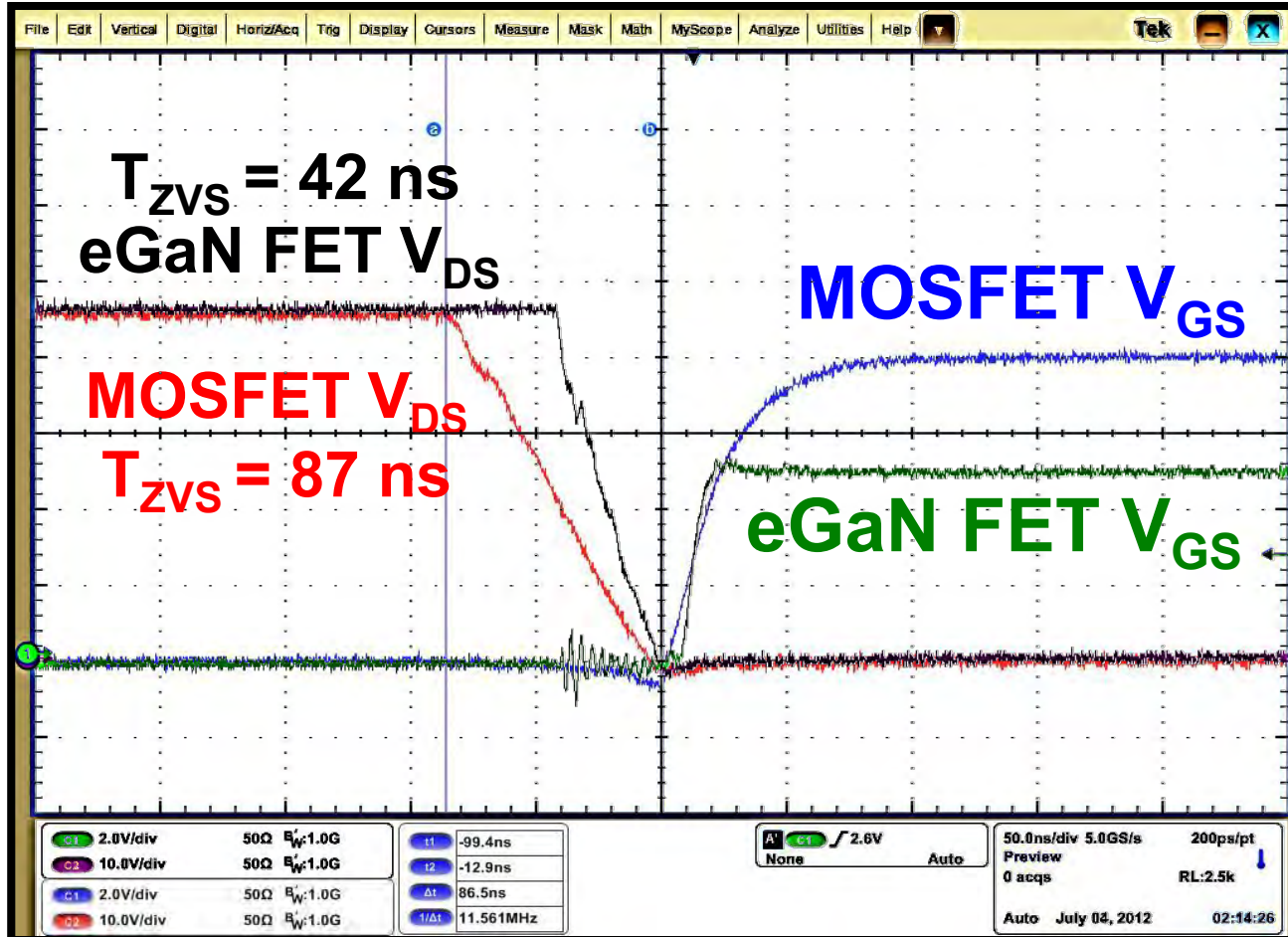
Primary Devices

Input Capacitors

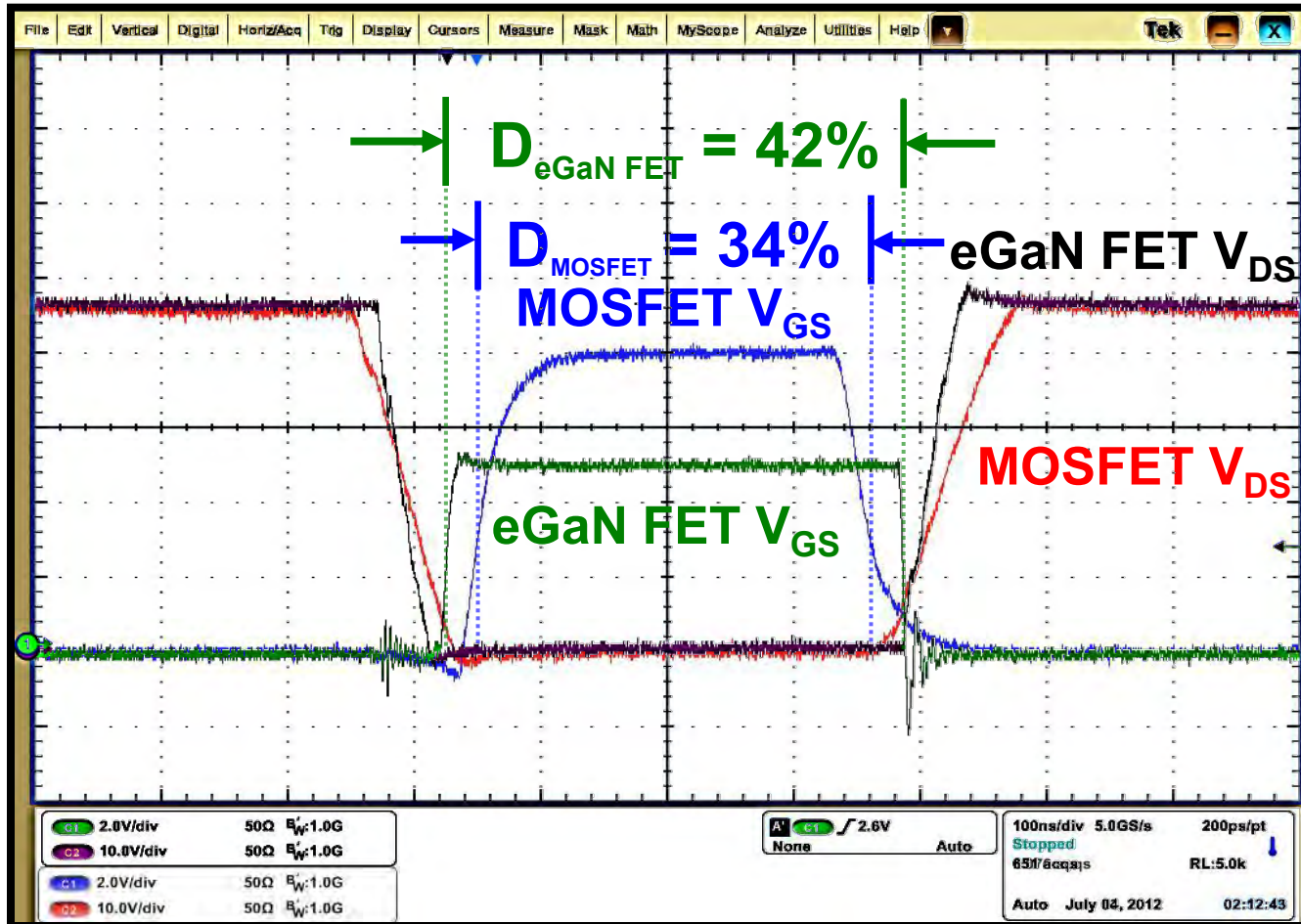


eGaN[®]FET

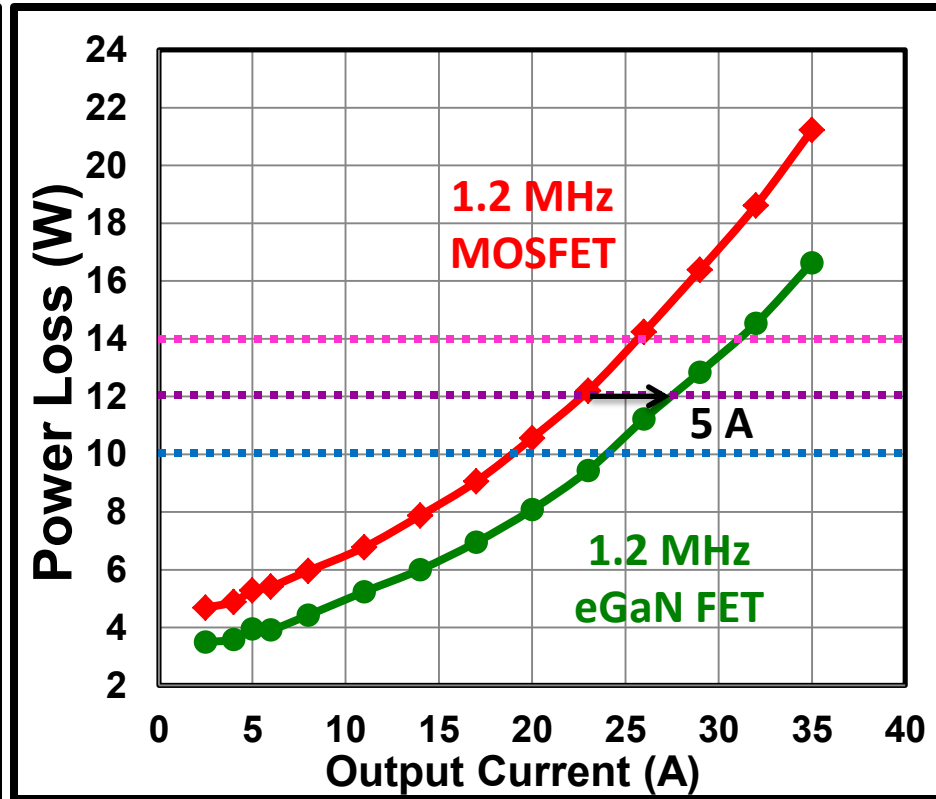
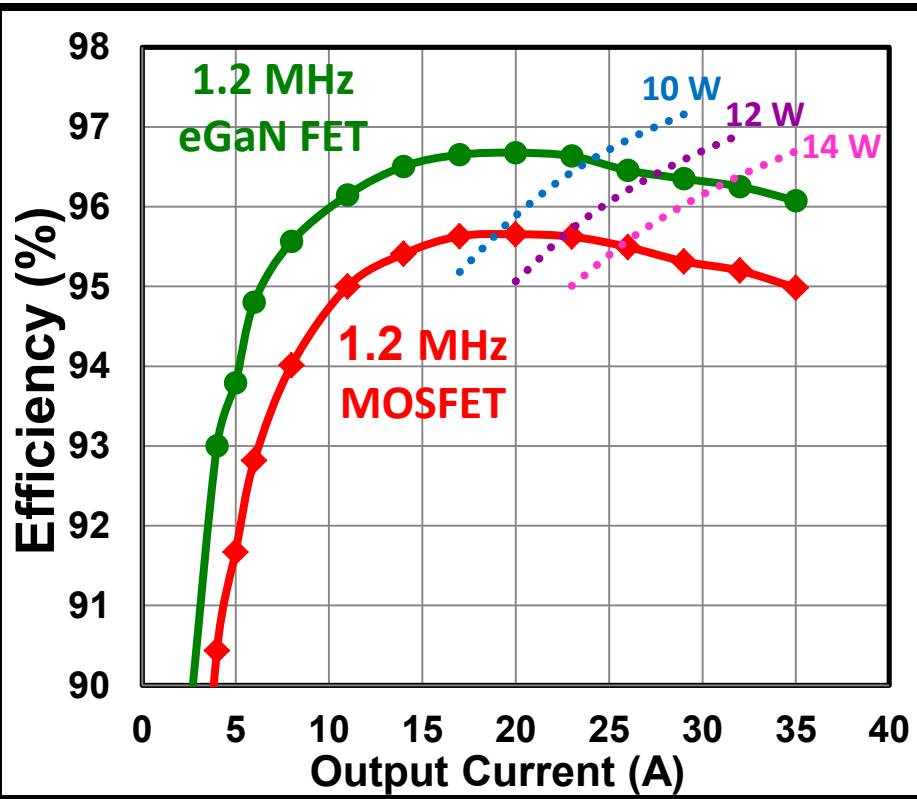
vs.



$f_{sw} = 1.2 \text{ MHz}$, $V_{IN} = 48 \text{ V}$, and $V_{OUT} \approx 12 \text{ V}$



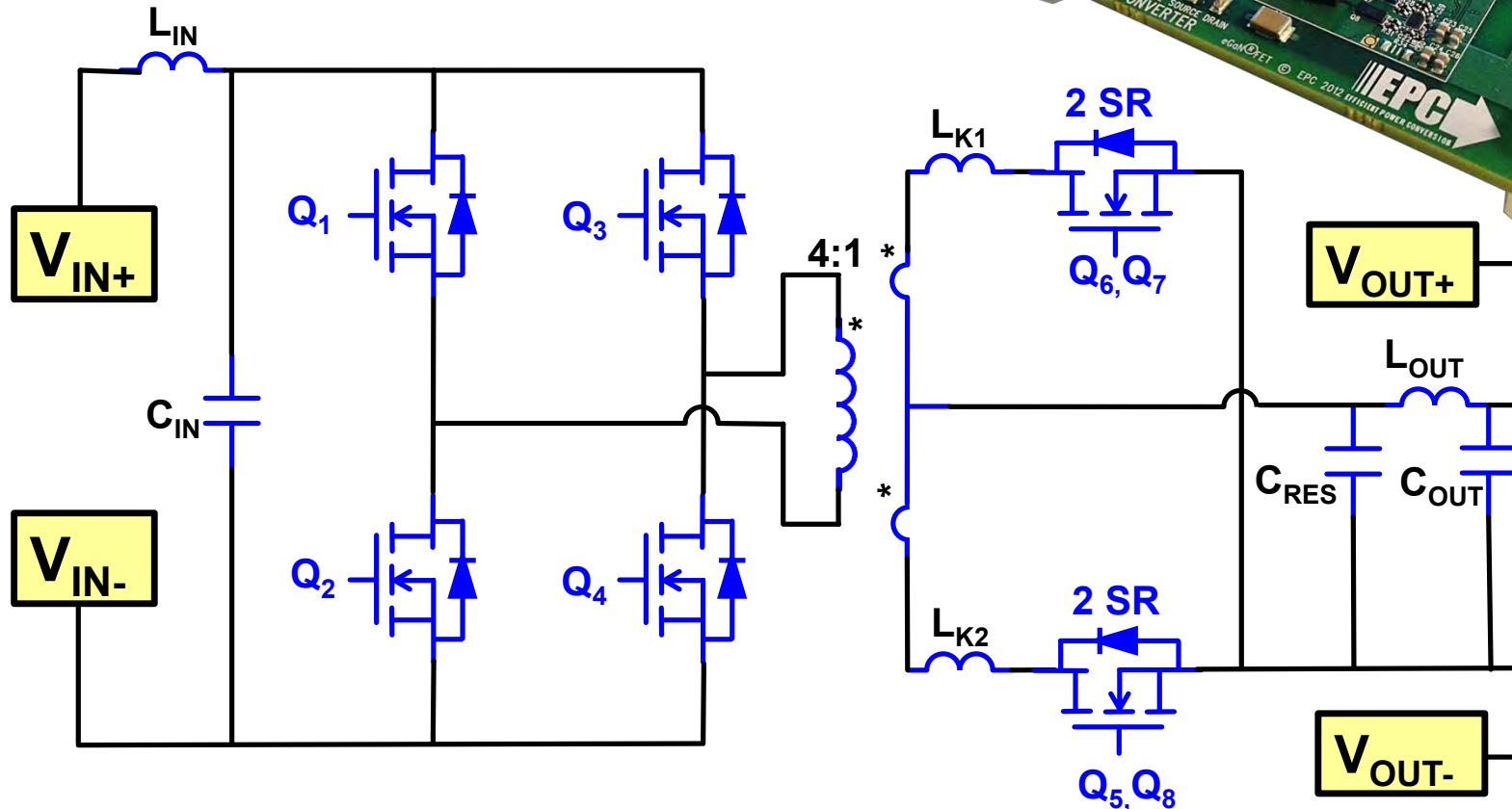
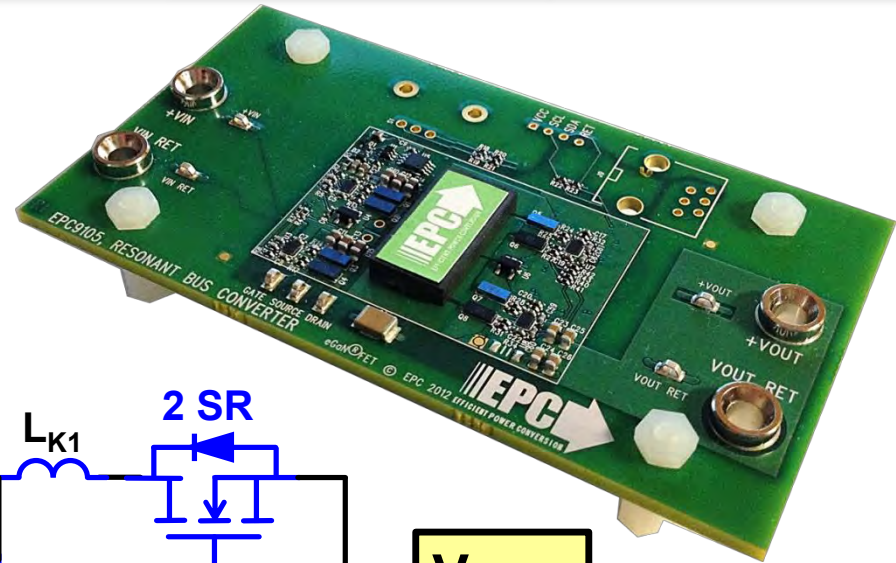
$f_{sw} = 1.2\text{ MHz}, V_{IN} = 48\text{ V}, \text{ and } V_{OUT} \approx 12\text{ V}$



$f_{sw} = 1.2 \text{ MHz}, V_{IN} = 48 \text{ V}, \text{ and } V_{OUT} \approx 12 \text{ V}$

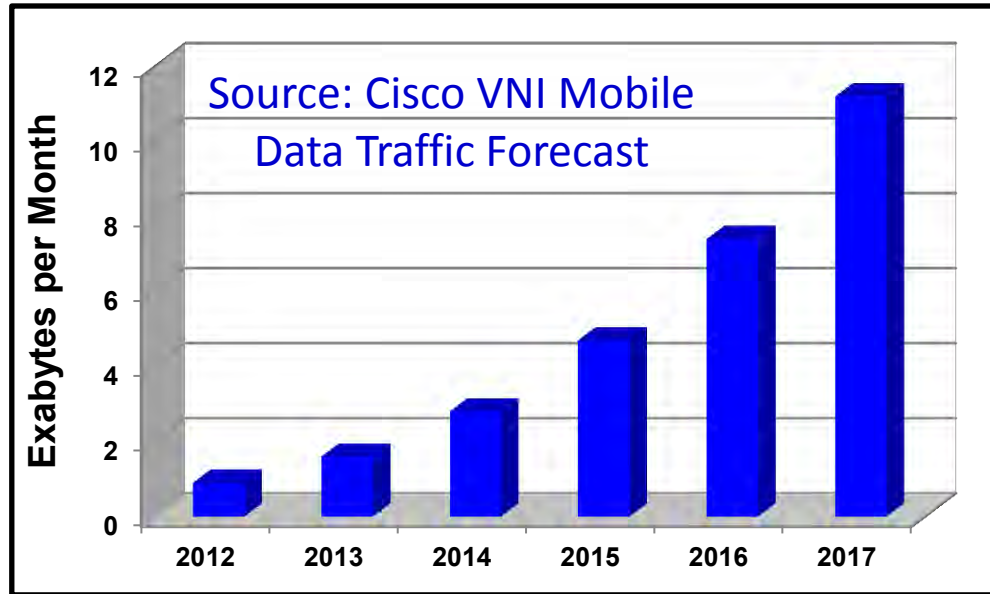
EPC9105 Demonstration Board

36 - 60 V_{IN}, 12 V_{OUT}, 350 W, 1.2 MHz

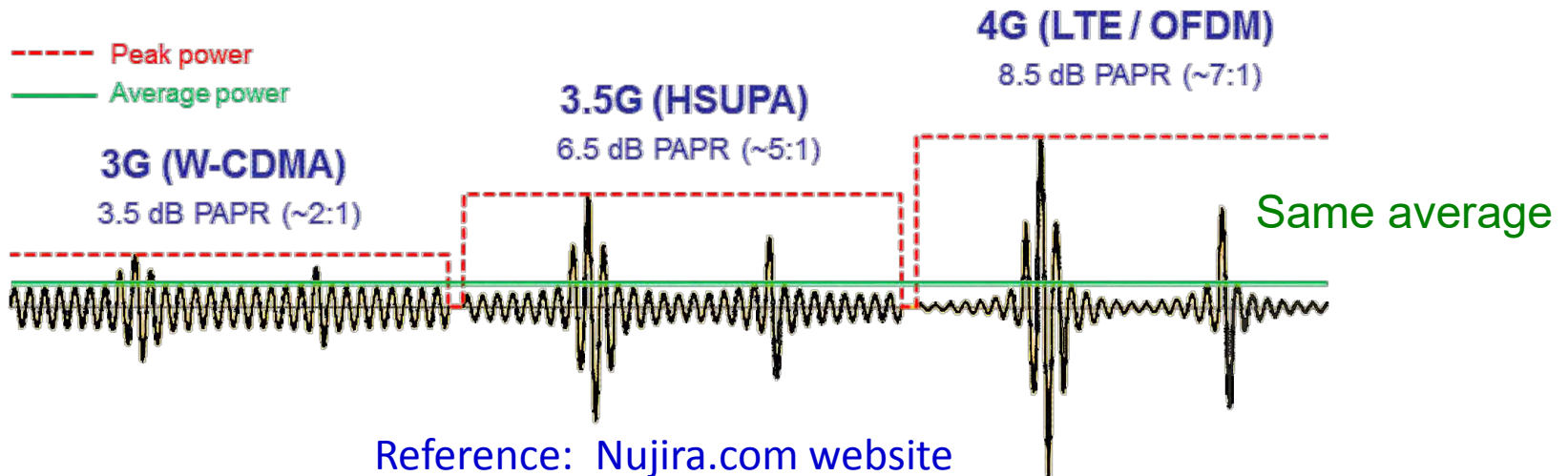


Envelope Tracking

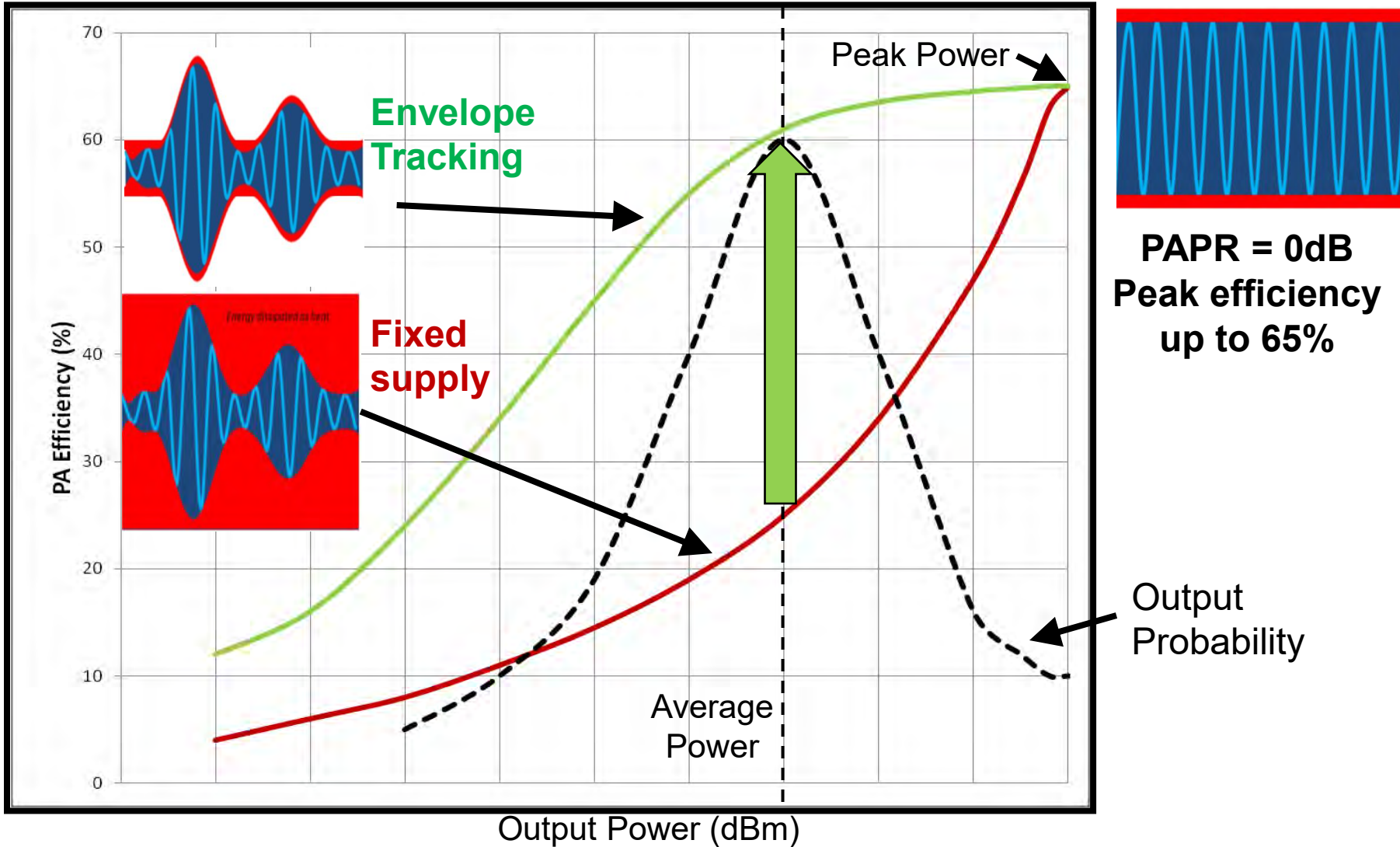
Why Envelope Tracking?

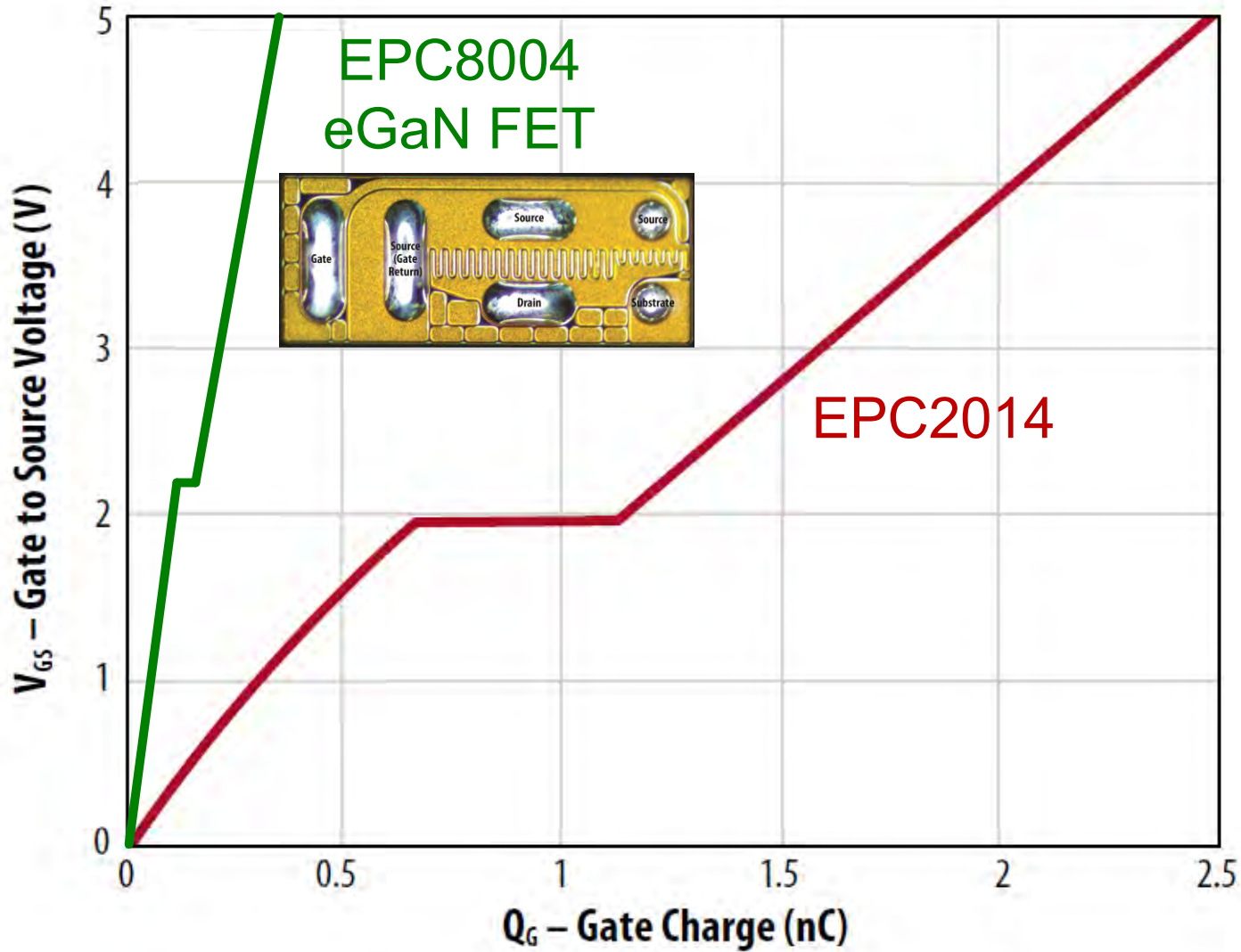


66% Compound annual growth rate (CAGR)

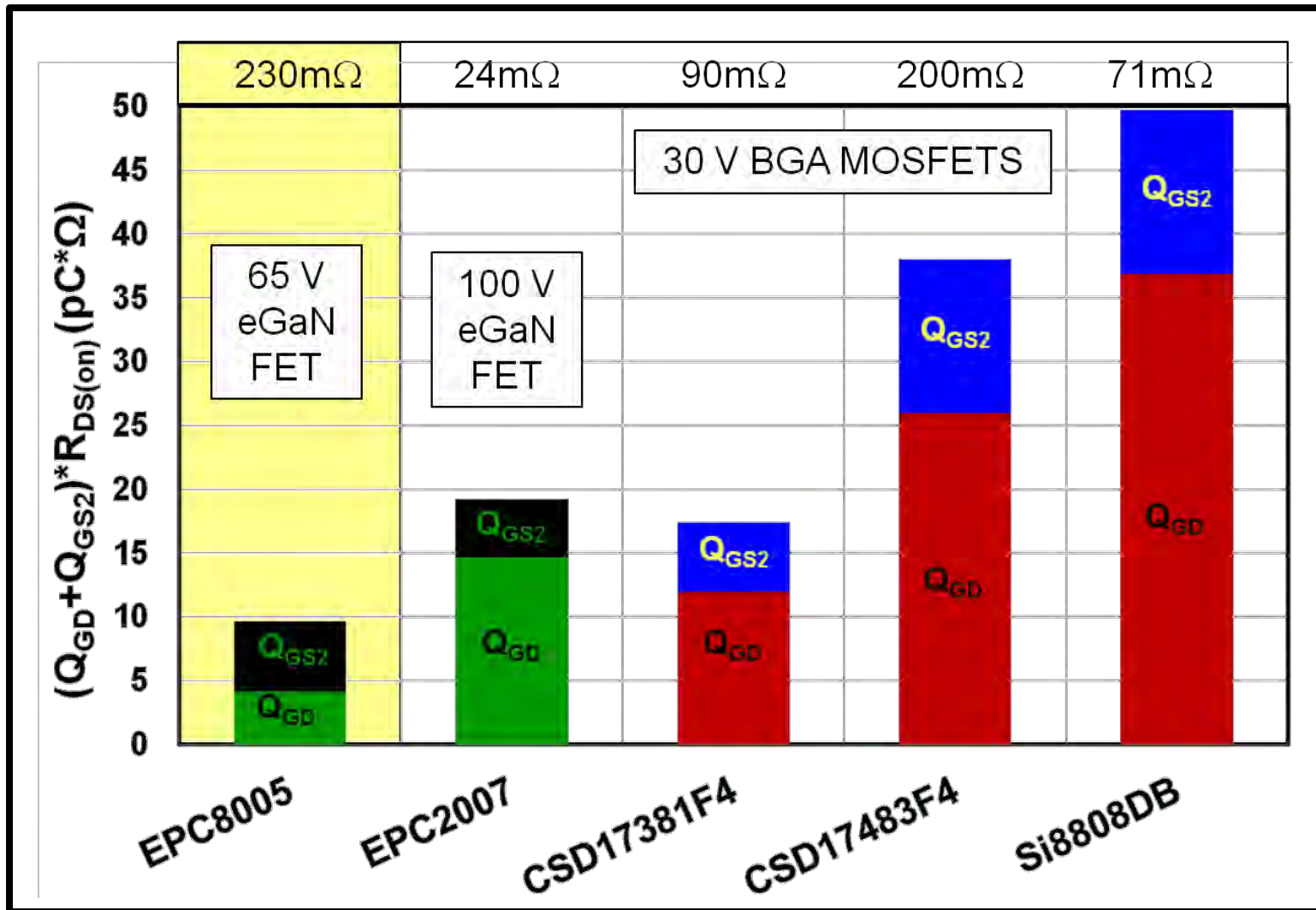


Envelope Tracking

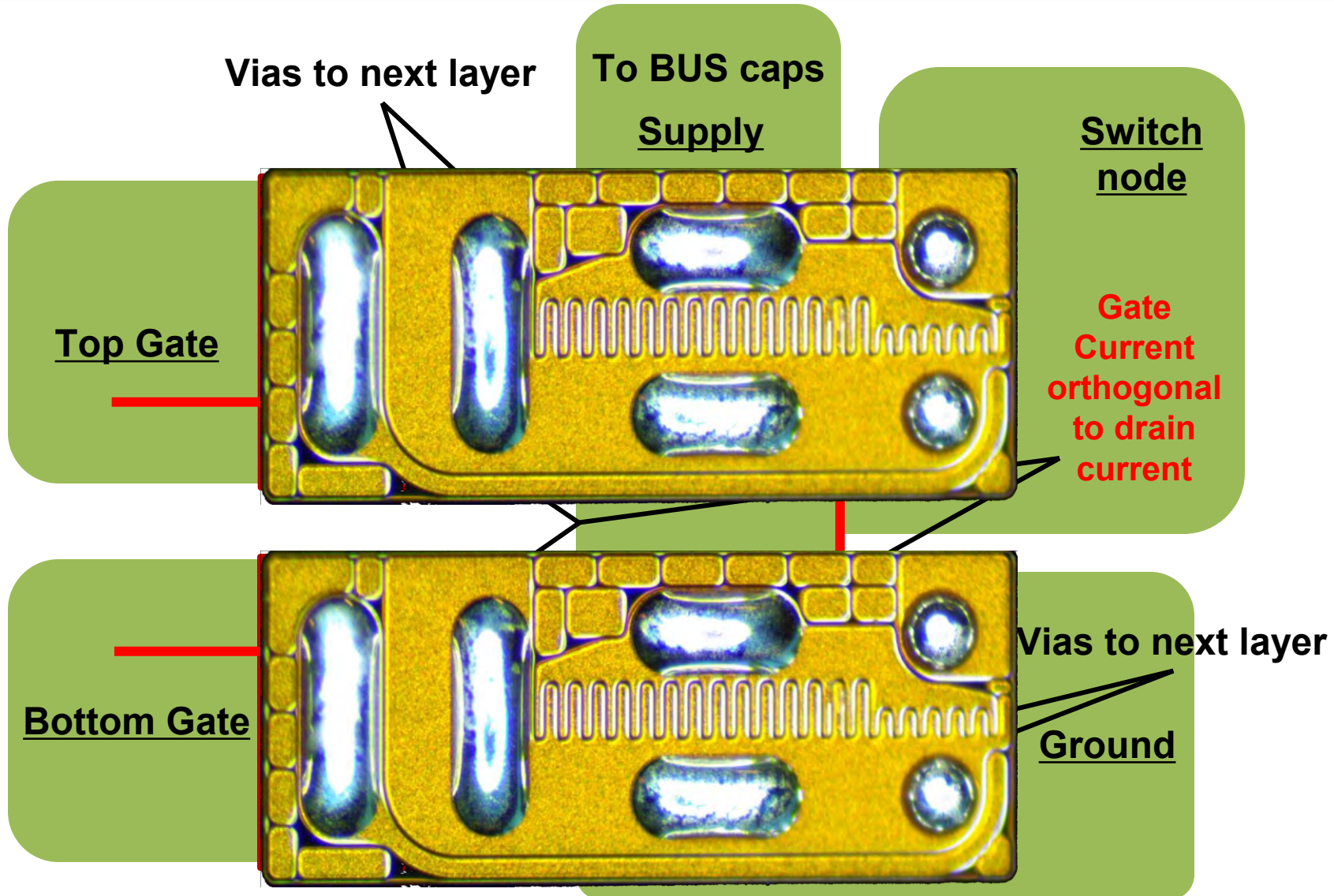




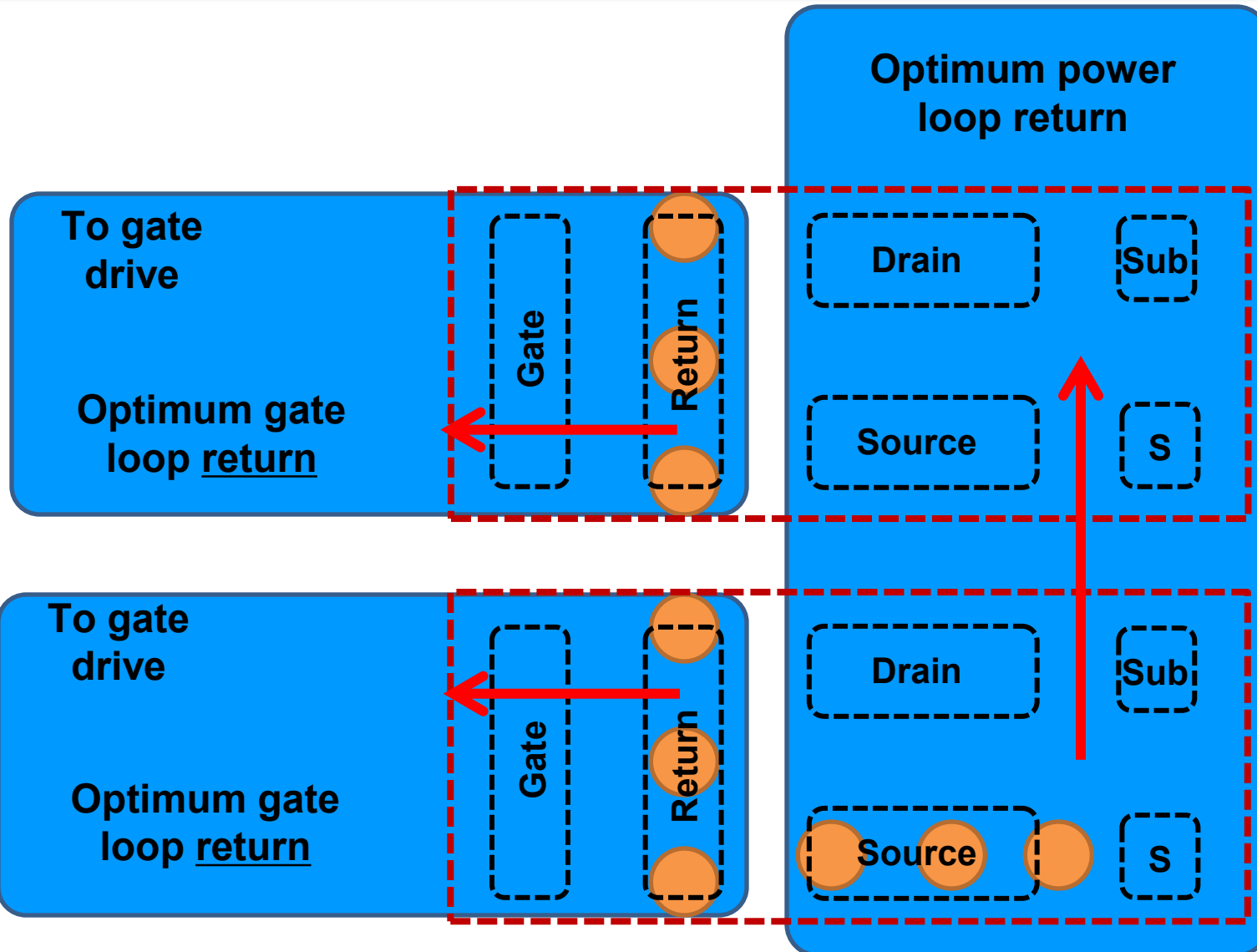
Hard Switching FOM

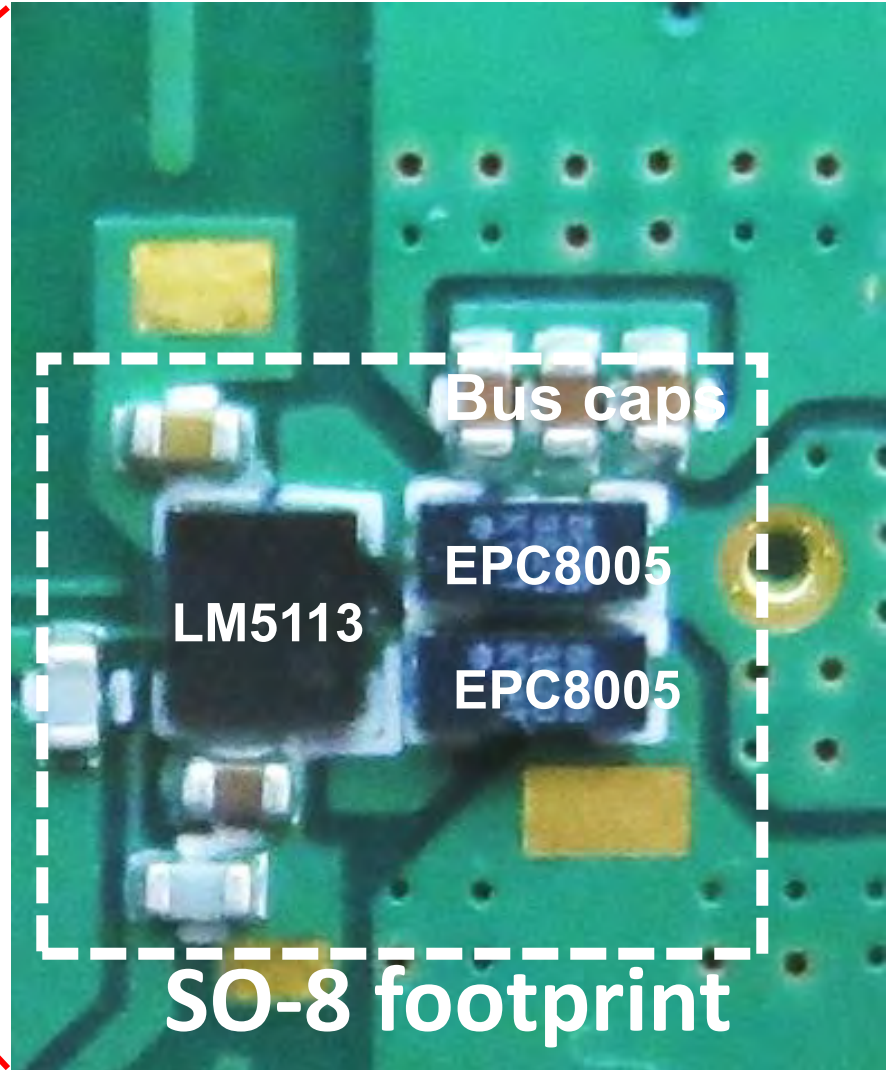
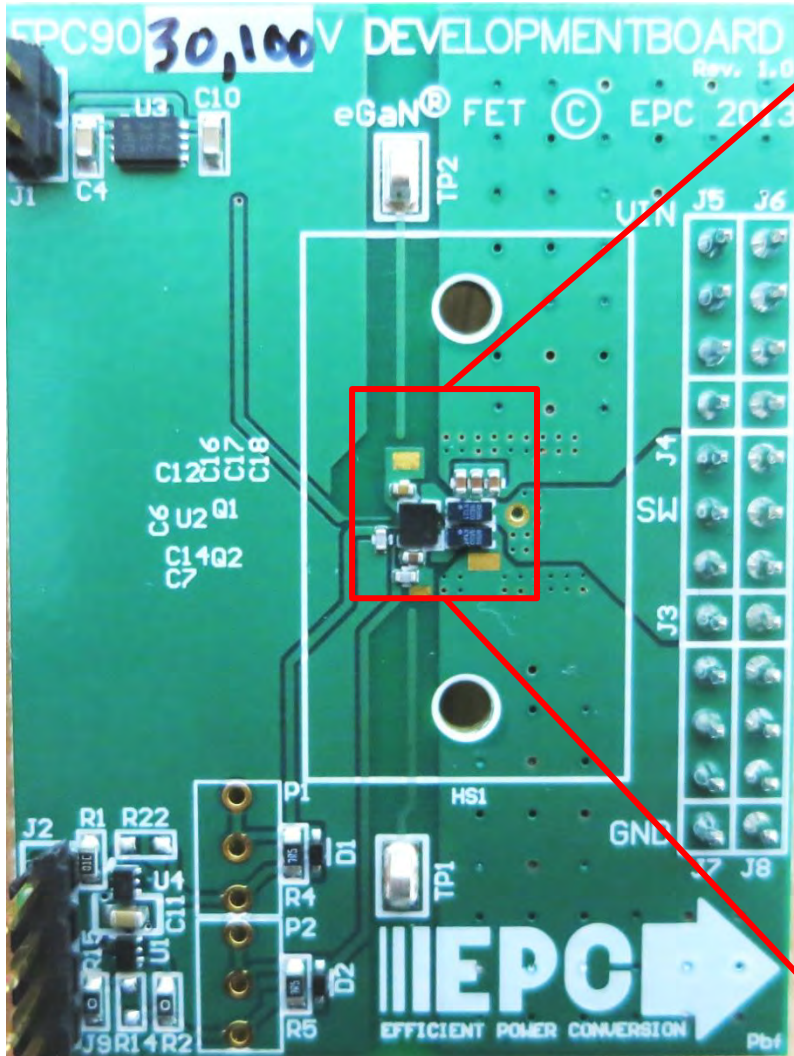


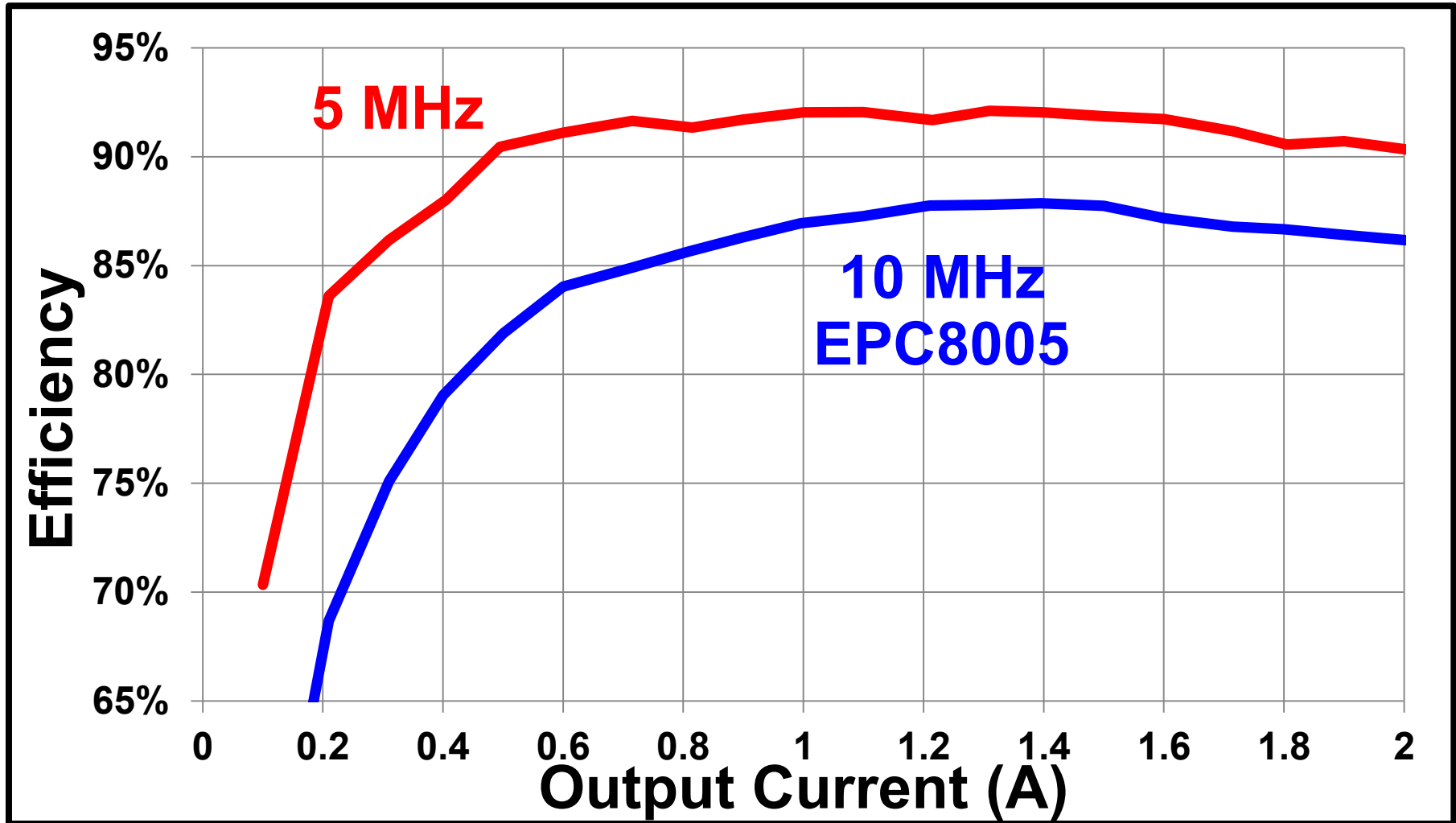
HB Layout – Top Layer



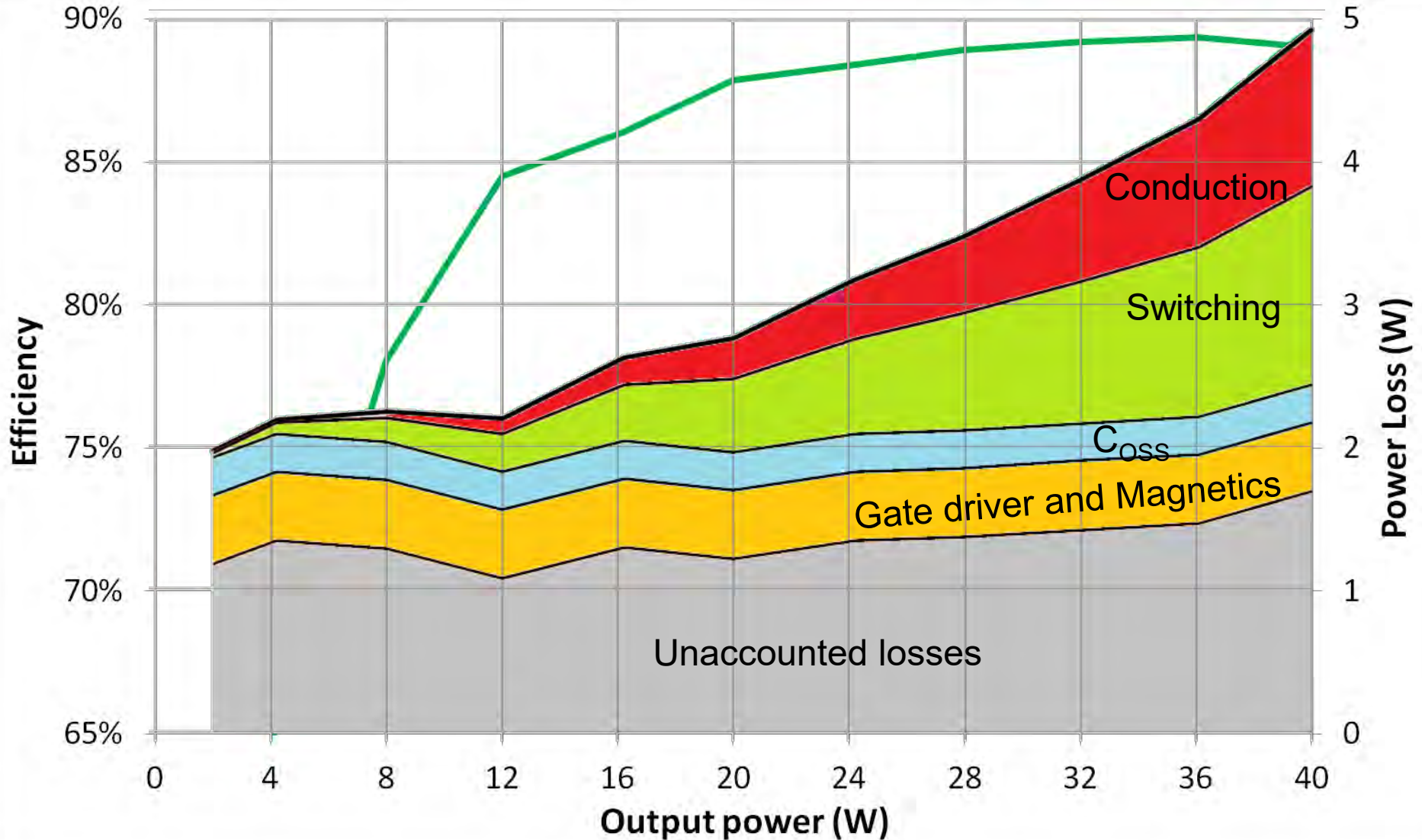
HB Layout – Inner Layer 1



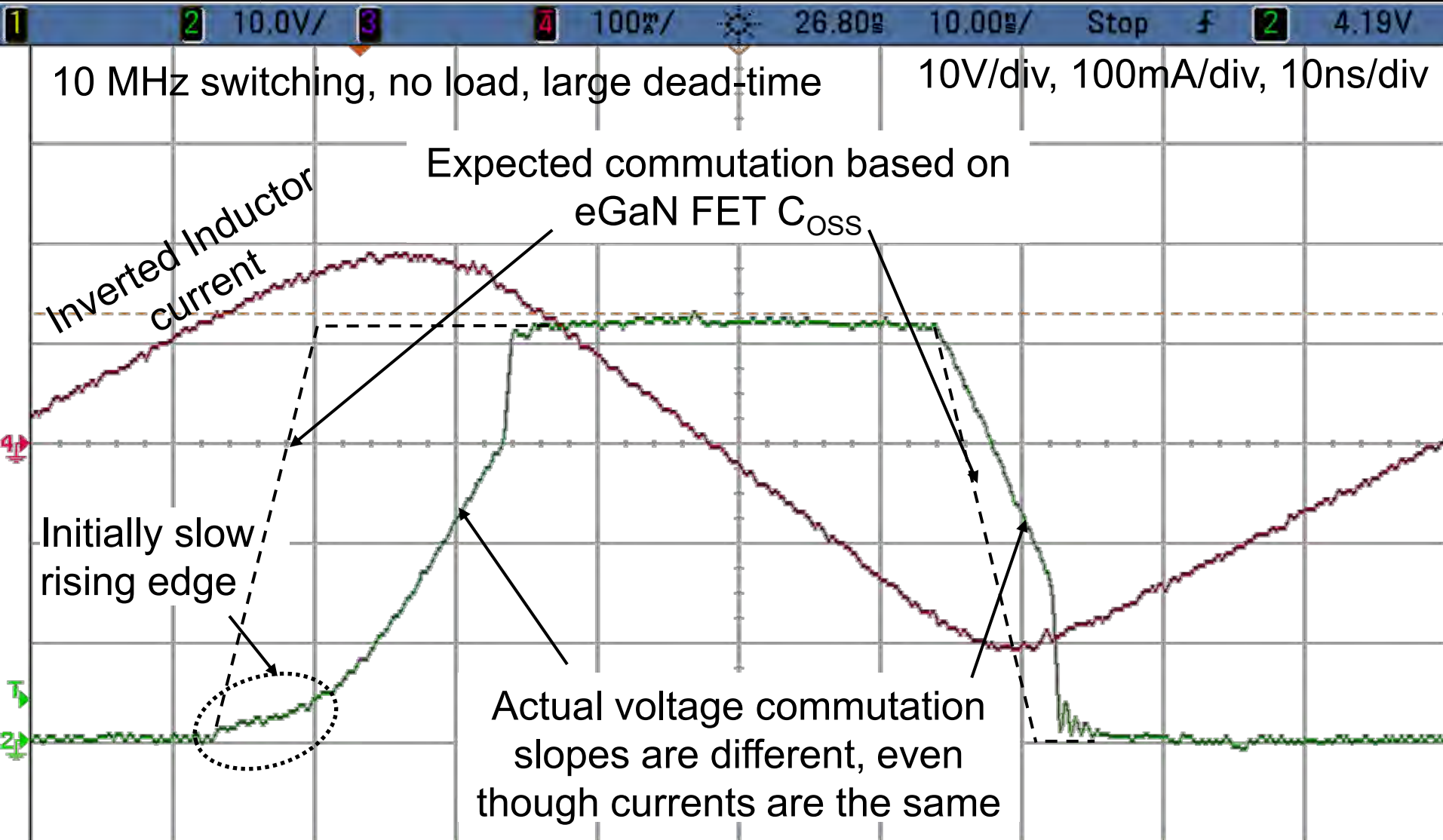




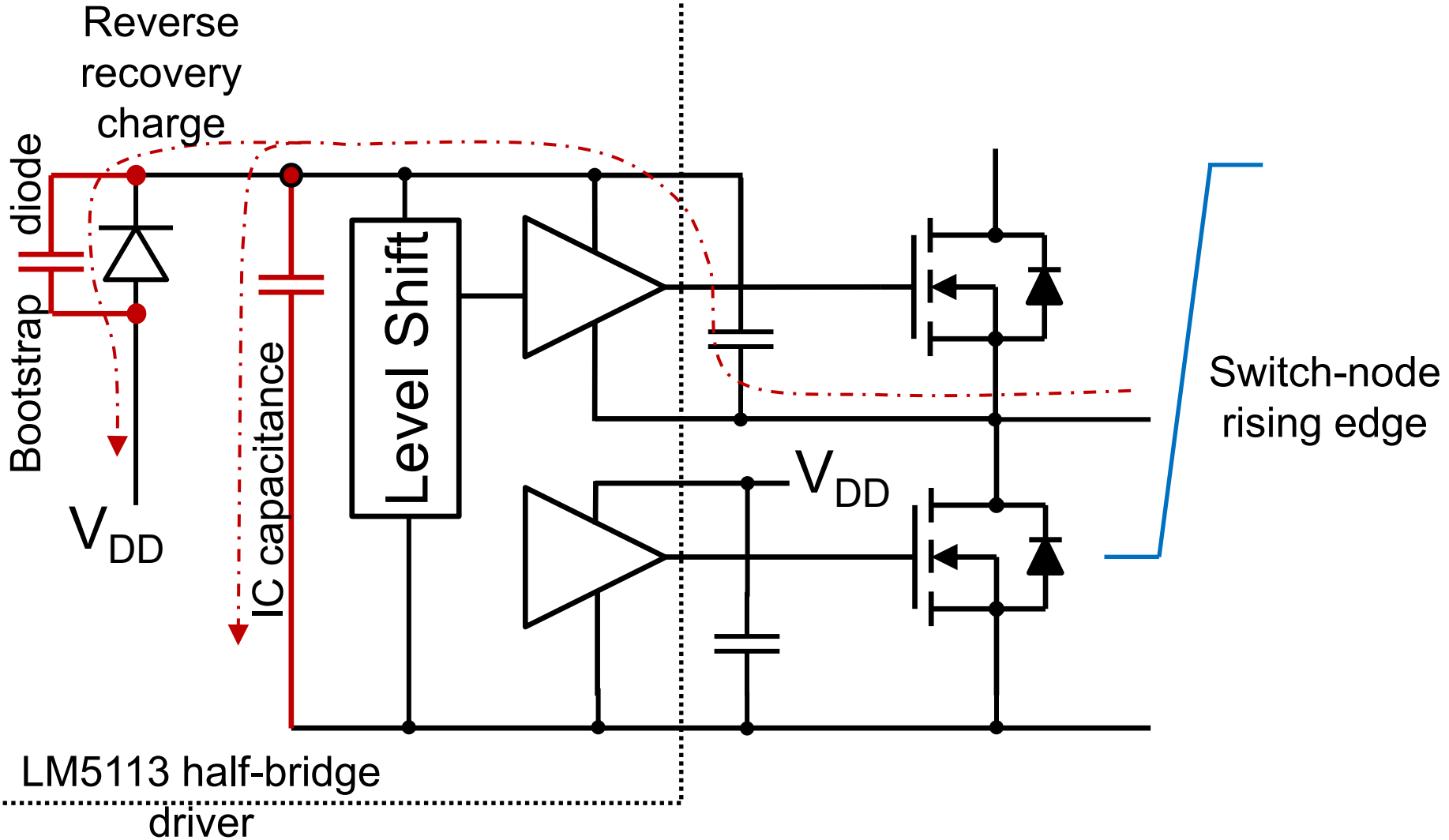
$V_{IN}=42\text{ V}$ $V_{OUT}=20\text{ V}$



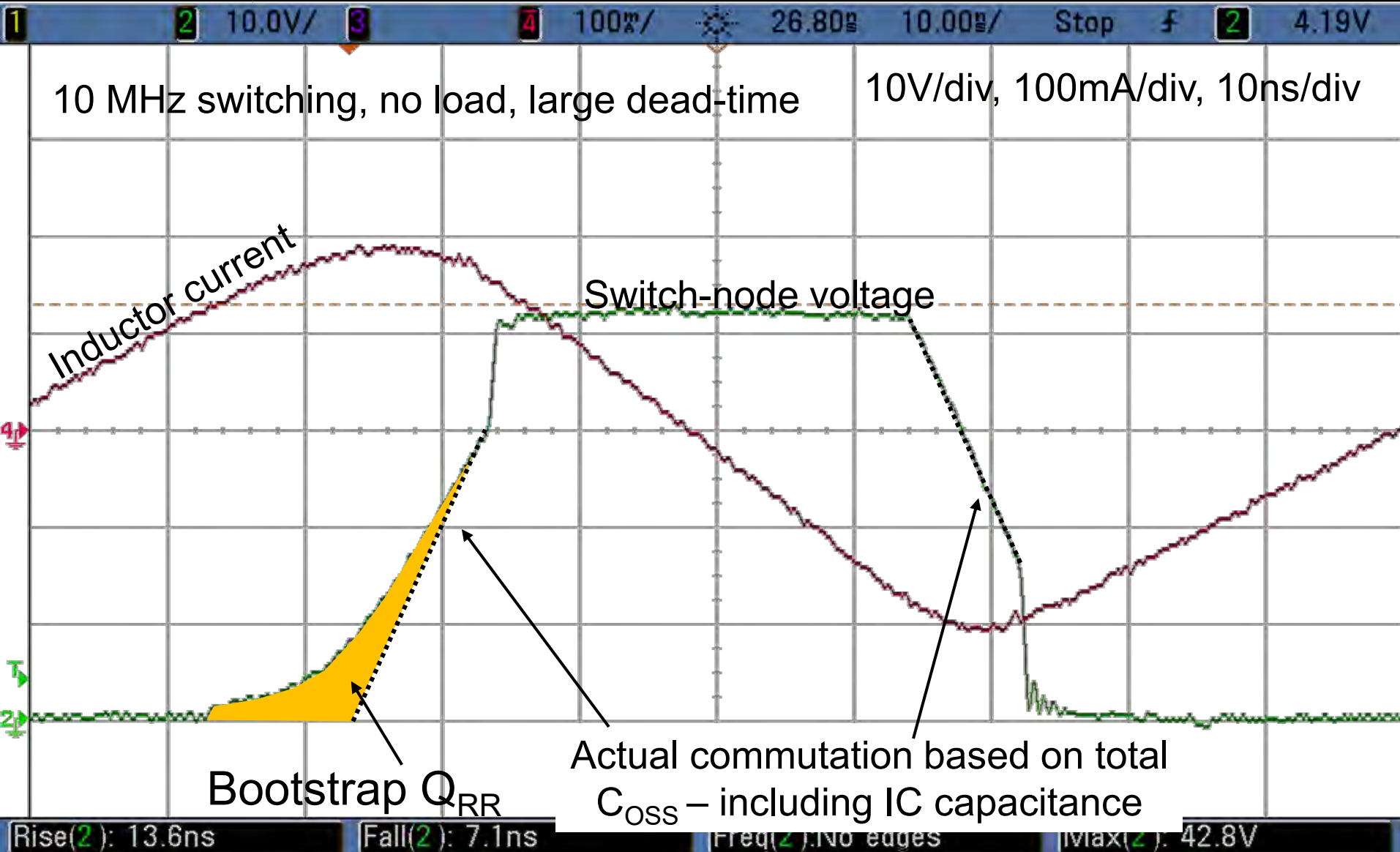
No-Load Switching

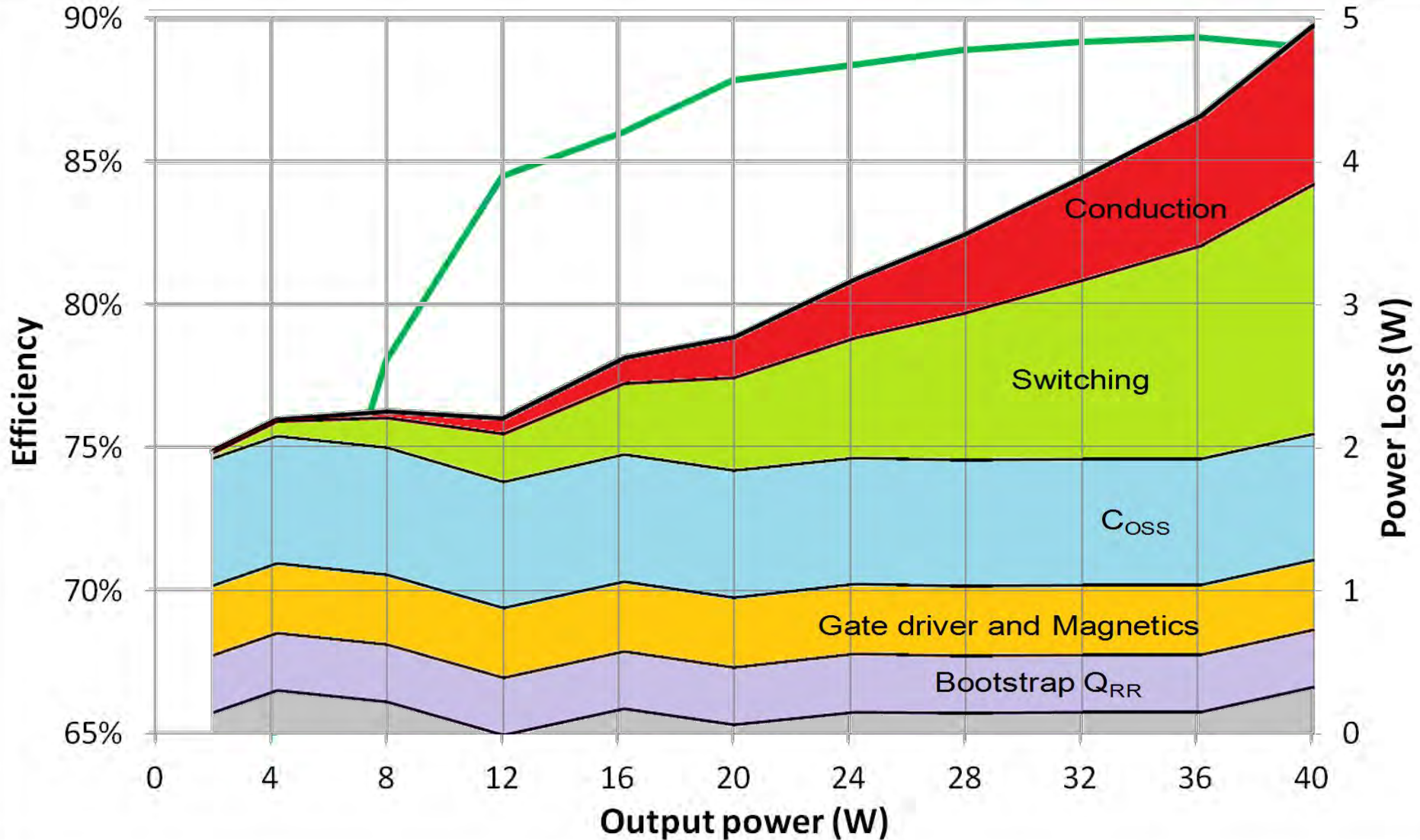


Rise(2): 13.6ns Fall(2): 7.1ns Freq(2): No edges Max(2): 42.8V

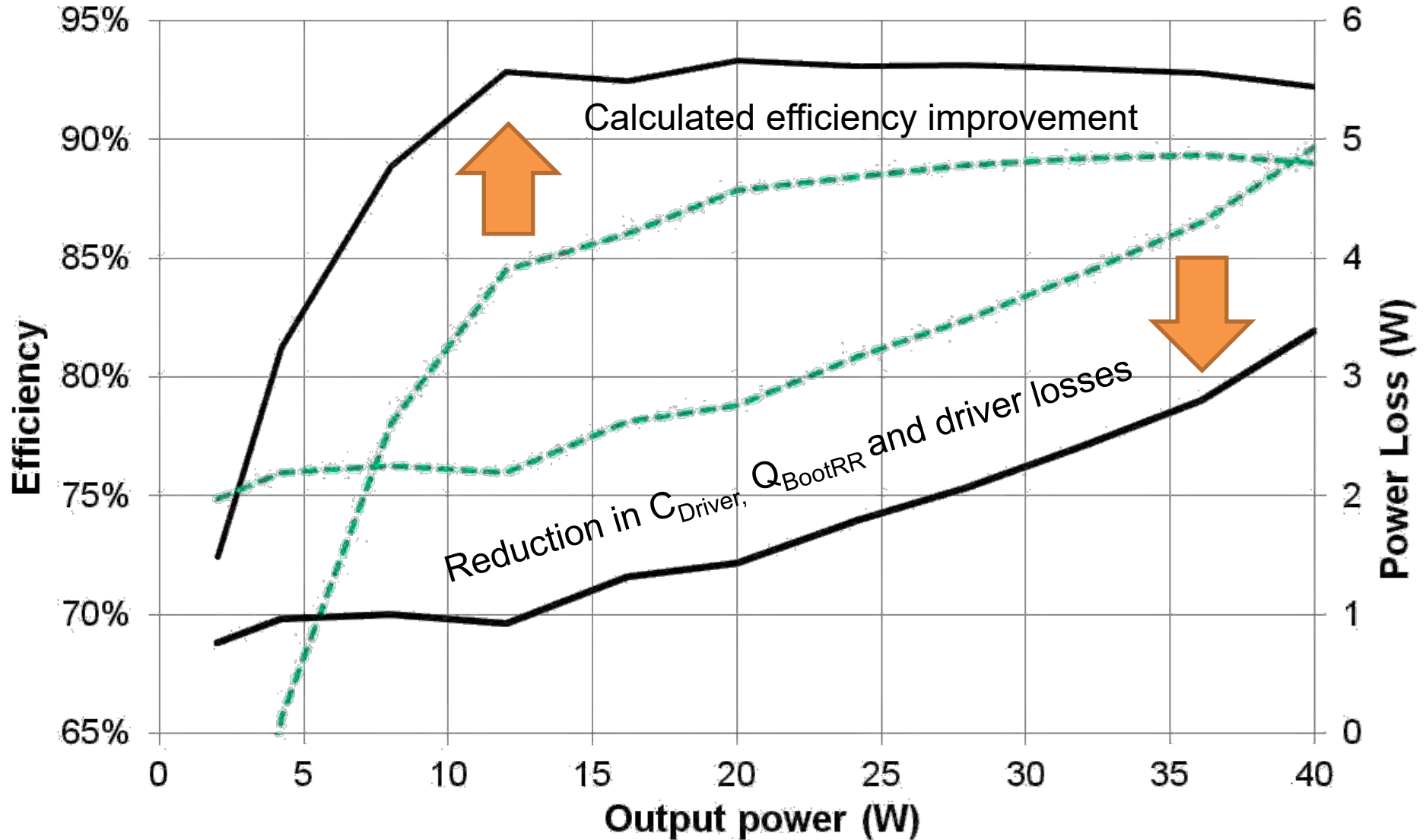


Loss Breakdown

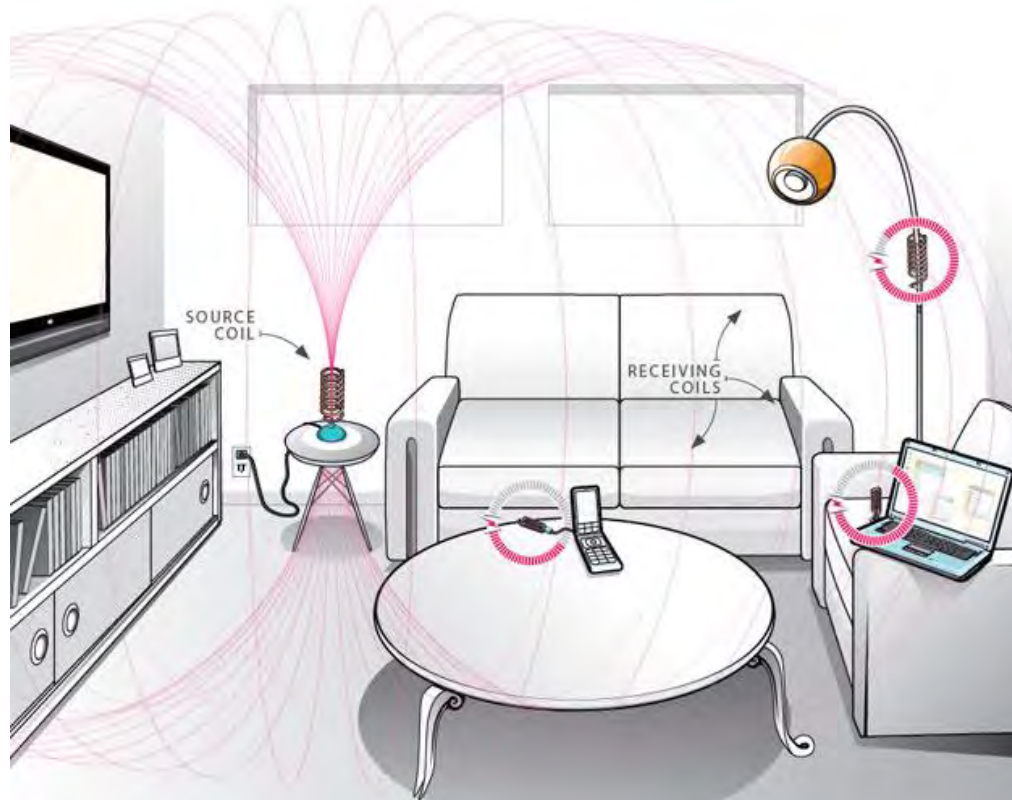




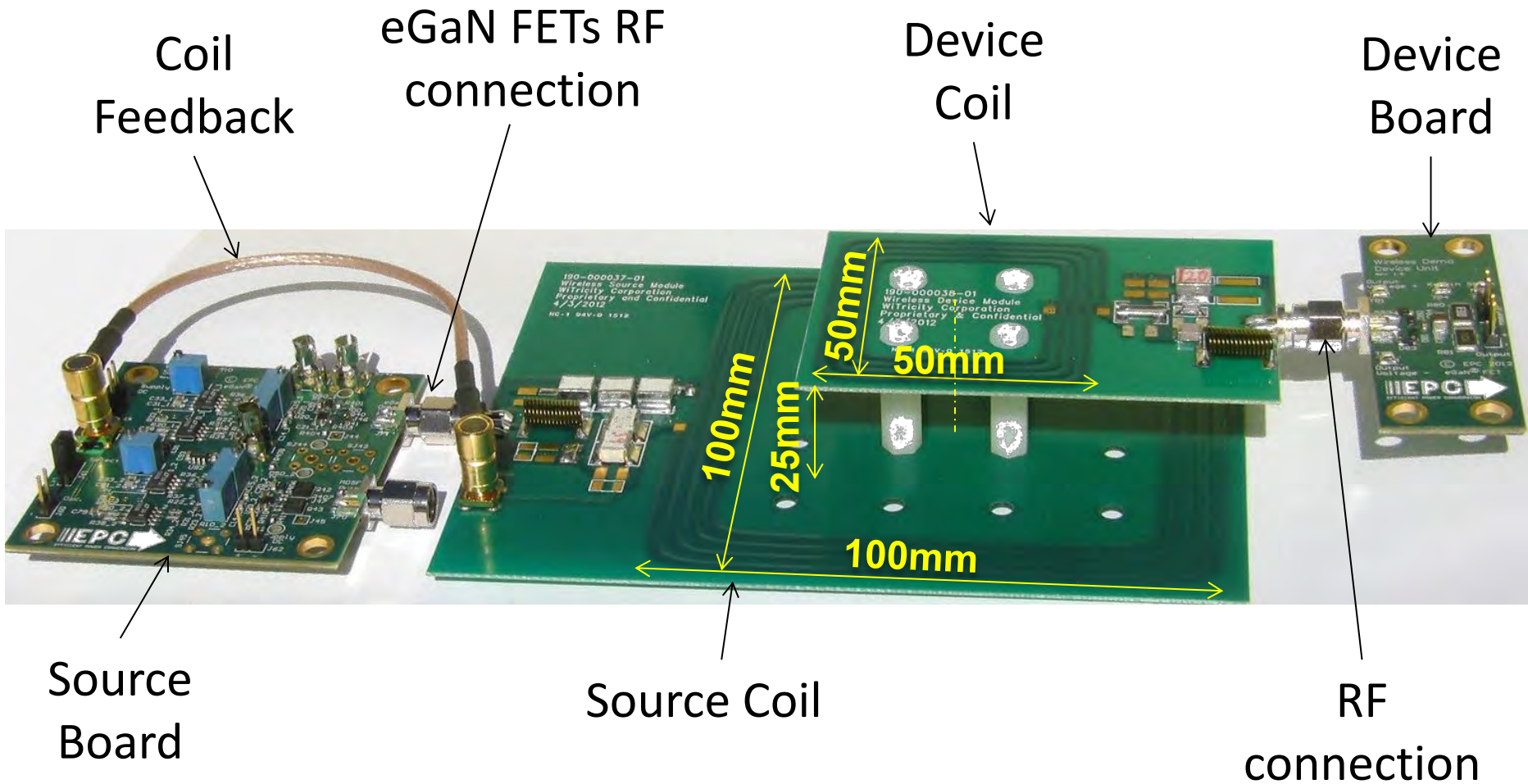
eGaN FET Limited Efficiency



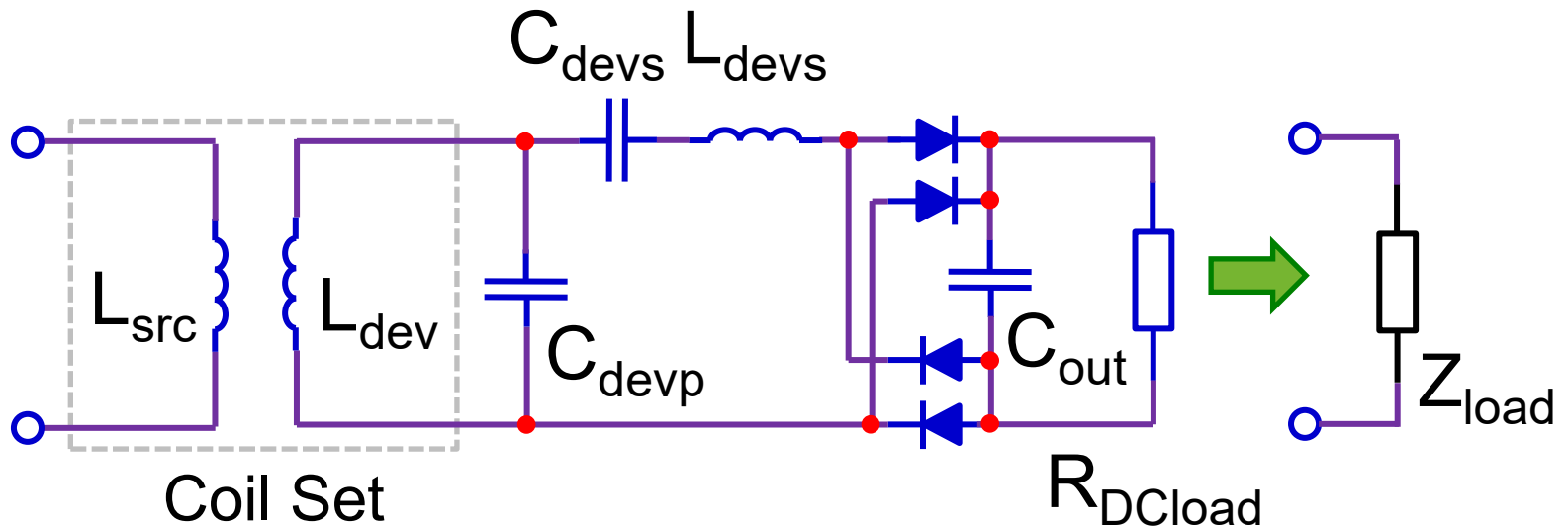
Wireless Power



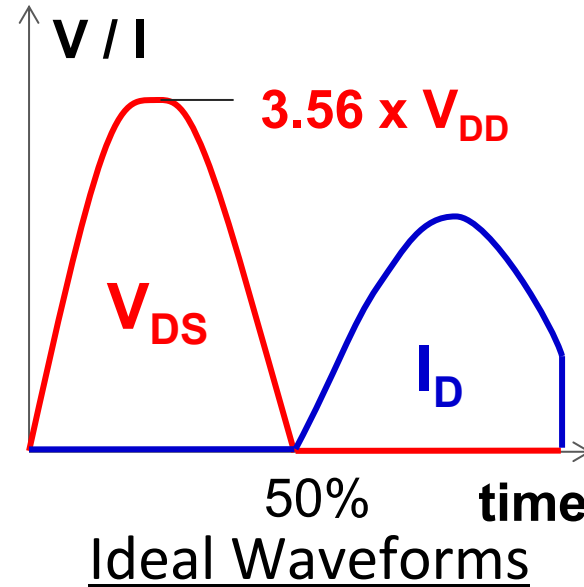
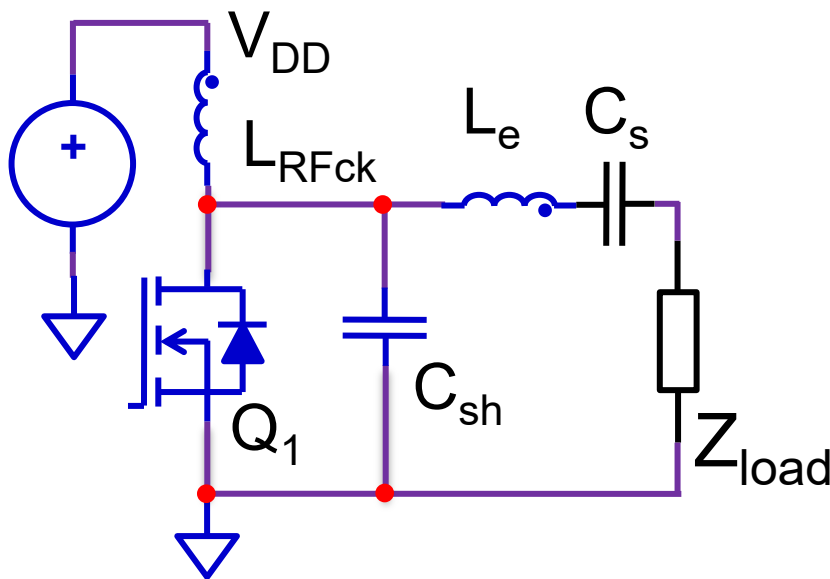
- The global wireless charging market is estimated to grow to \$10B by 2018, a CAGR of 42.6%
- eGaN FETs enable higher efficiency and operation at safer frequencies



Simplified representation of coil-set for easy comparison between topologies

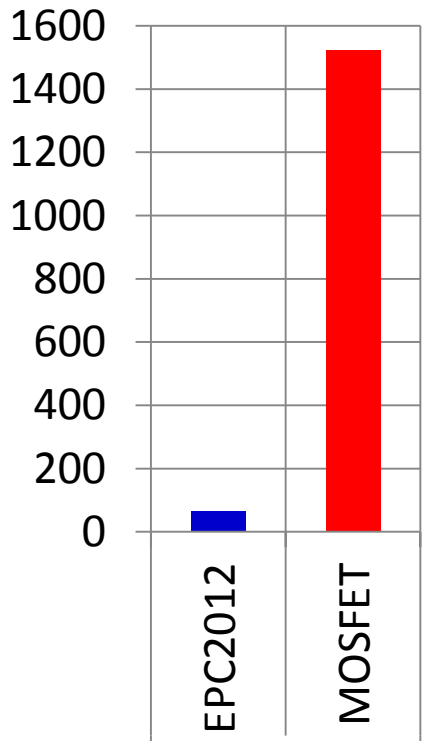


- Switch voltage rating $\geq 3.56 \cdot \text{Supply } (V_{DD})$.
- C_{OSS} “absorbed” into matching network.
- Susceptible to load variation - high FET losses.
- Coil voltage $\approx 0.707 \cdot V_{DD} [V_{RMS}]$.



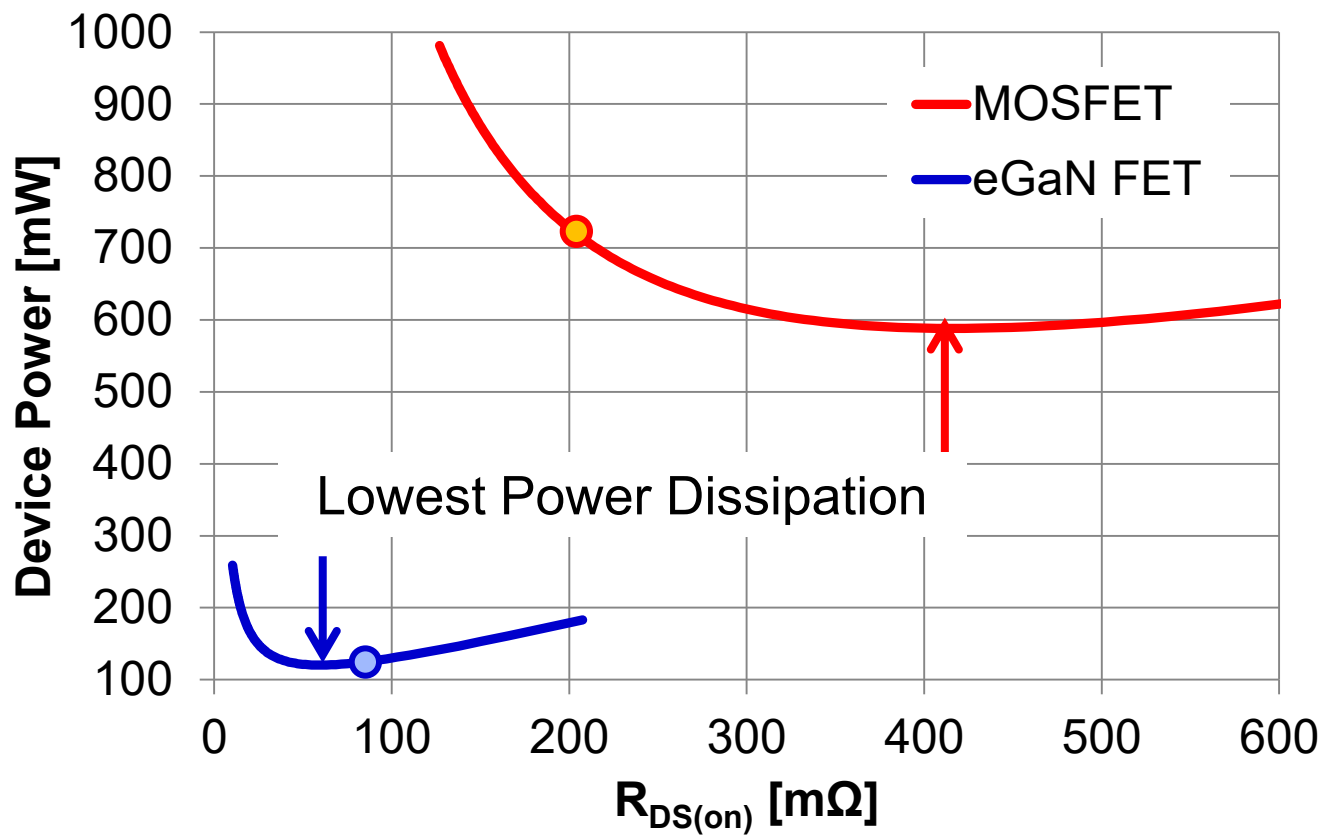
FoM_{WPT} [nC·mΩ]

SE-CE



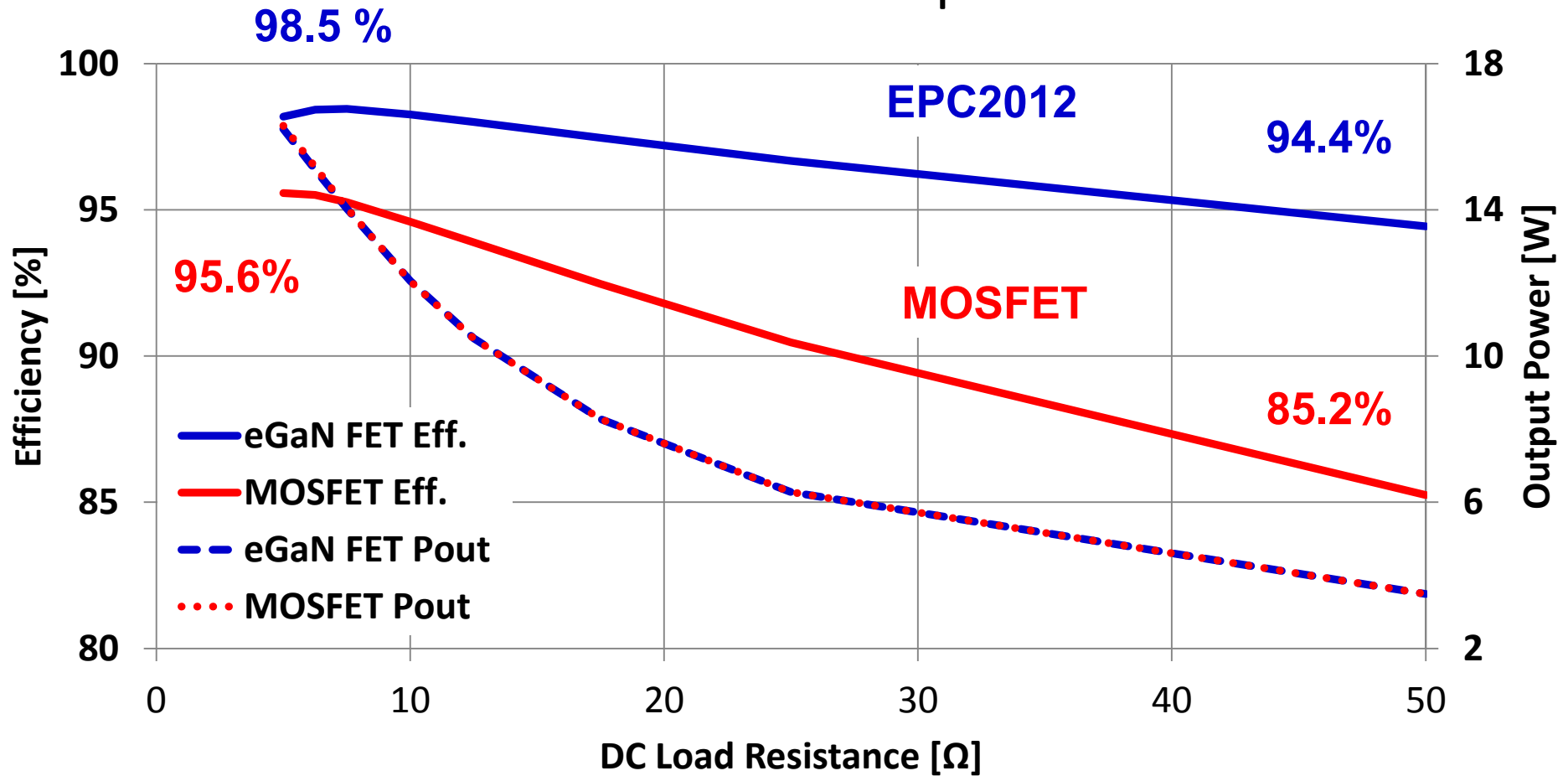
Gate Power dominant ←

Conduction Loss dominant →

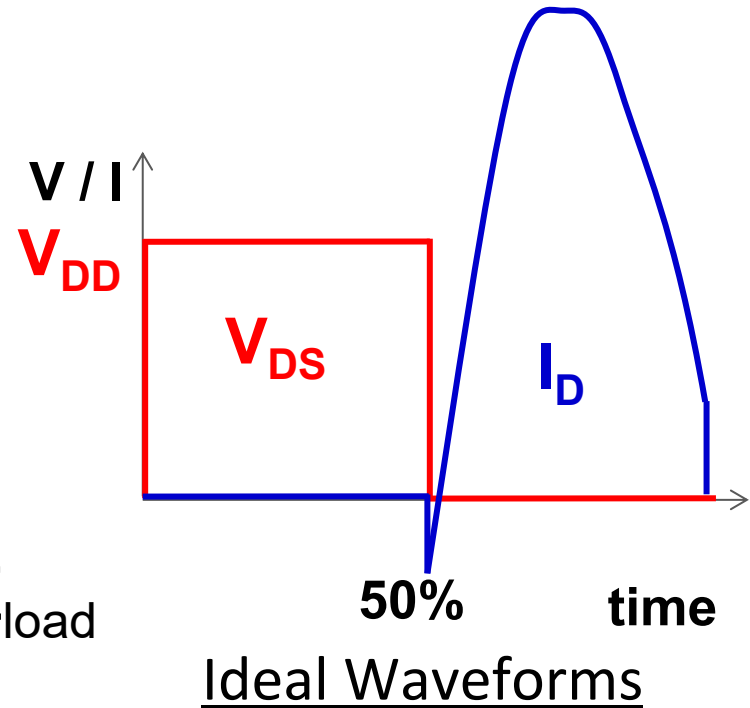
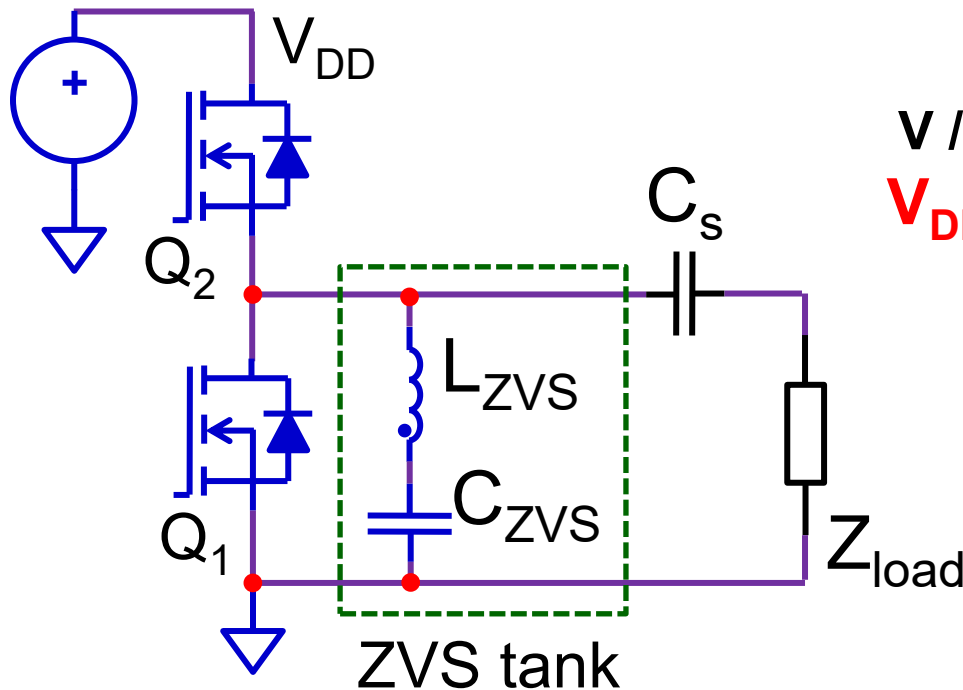


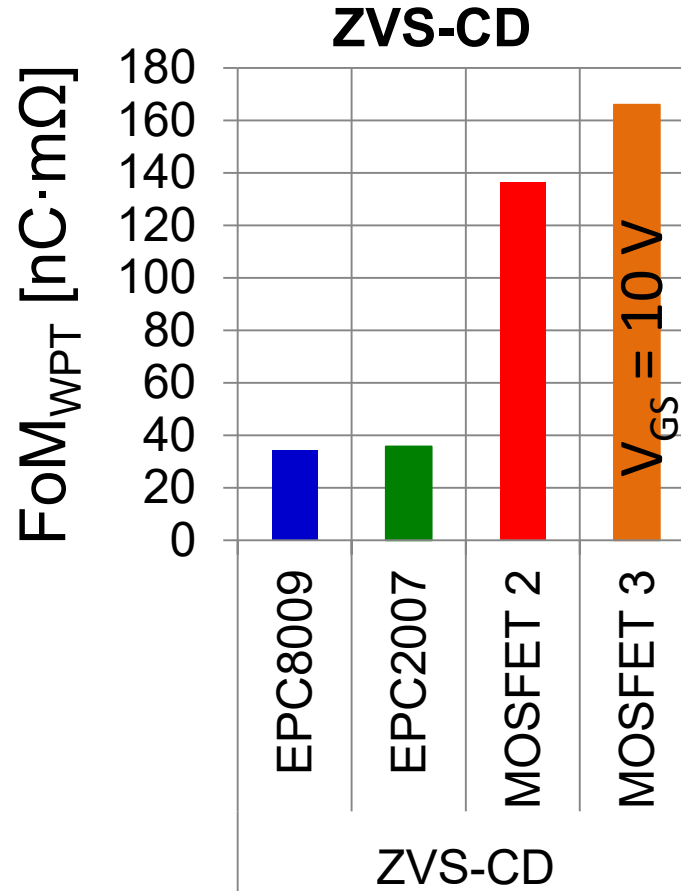
$$FOM_{WPT} = R_{DS(on)} \cdot (Q_G - Q_{GD})$$

Peak Power Device losses = 279 mW
 No Heat-Sink Required

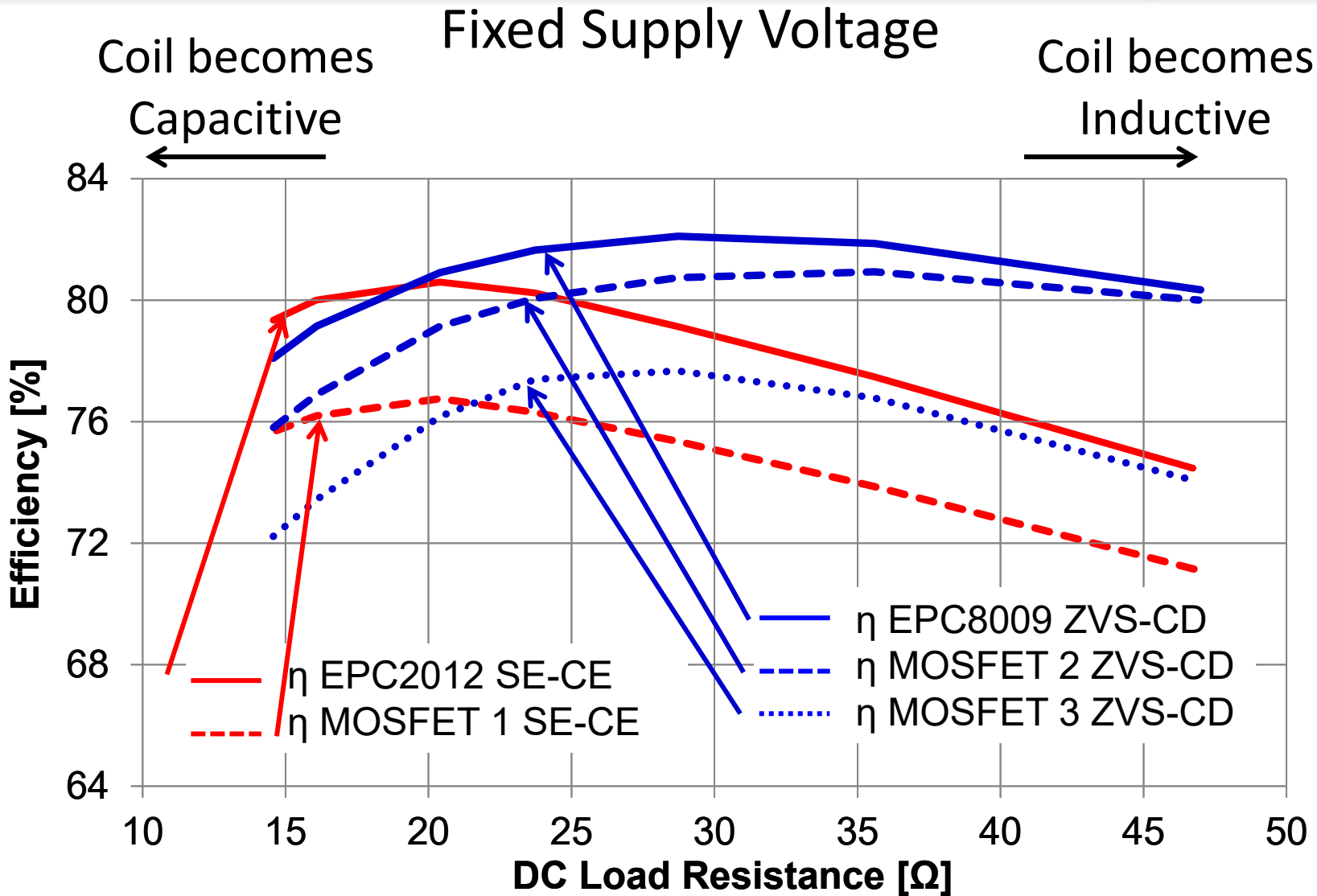


- Switch voltage rating = Supply (V_{DD}).
- C_{OSS} voltage is transitioned by the ZVS tank .
- ZVS tank circuit does not carry load current.
- Coil voltage = $\frac{1}{2} \cdot V_{DD}$ [V_{RMS}].



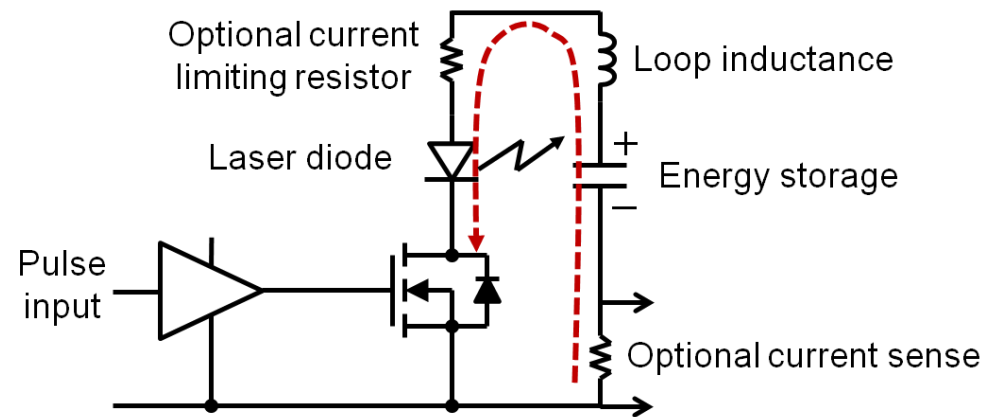
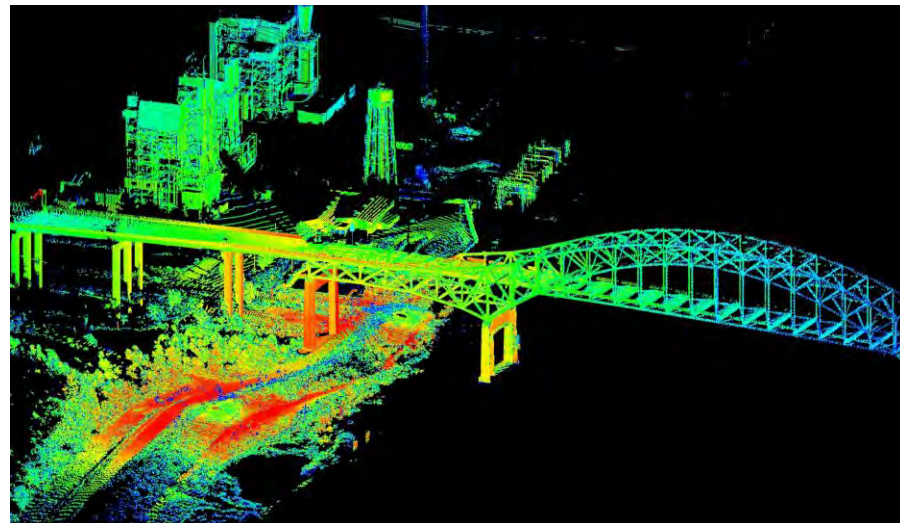


$$FOM_{WPT} = R_{DS(on)} \cdot (Q_G - Q_{GD})$$

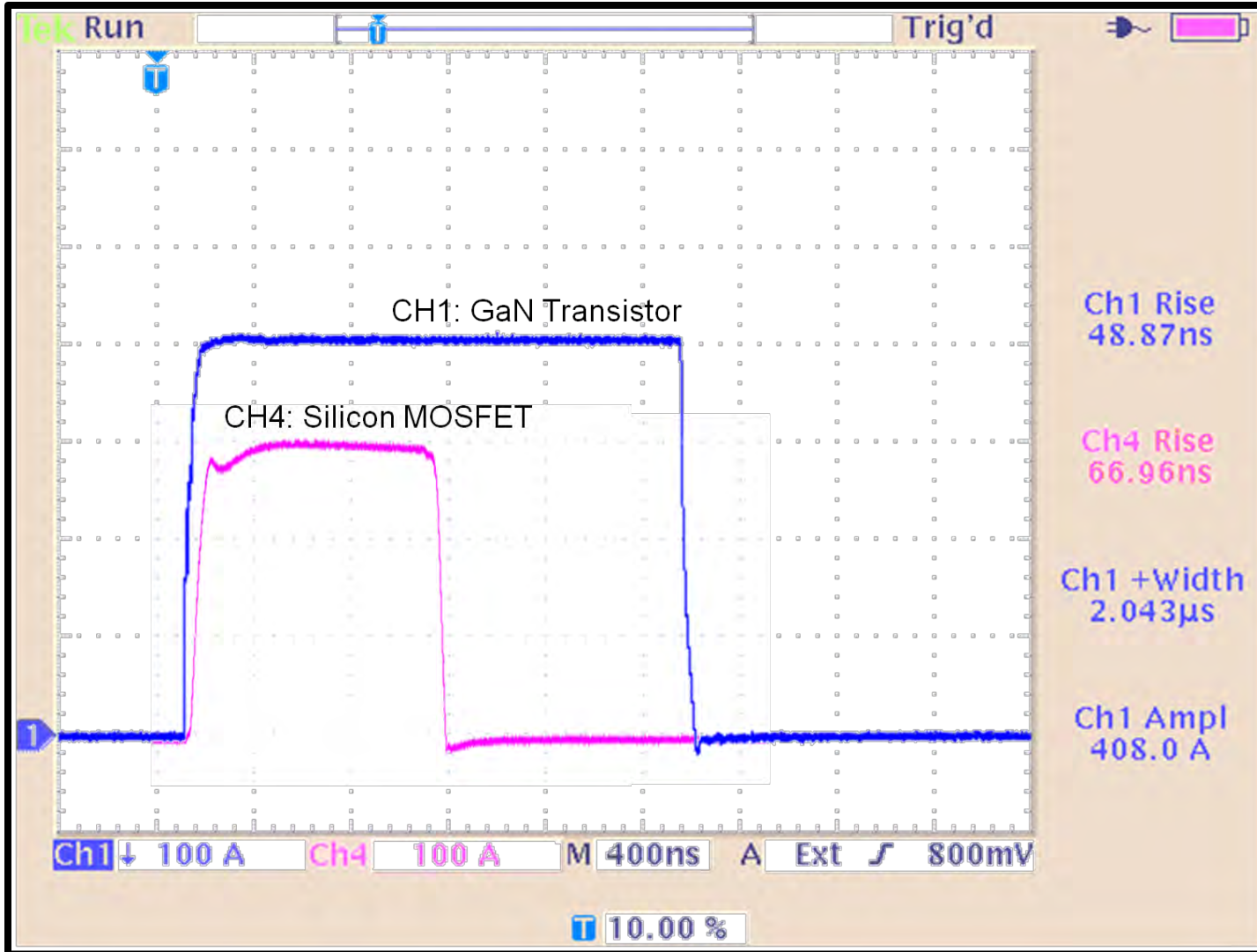


LiDAR

- Autonomous vehicles
- Video games
- Geology
- Agriculture



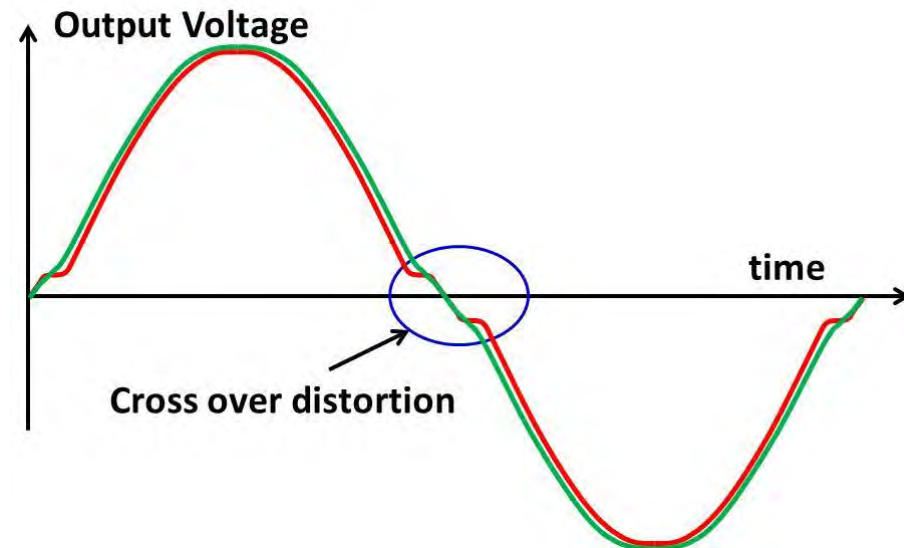
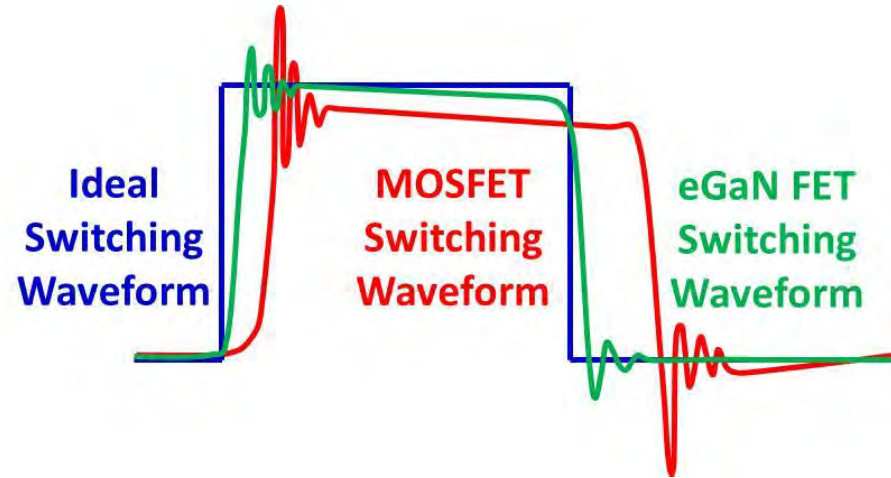
http://www.usgs.gov/blogs/features/usgs_top_story/hurricane-season-is-here/



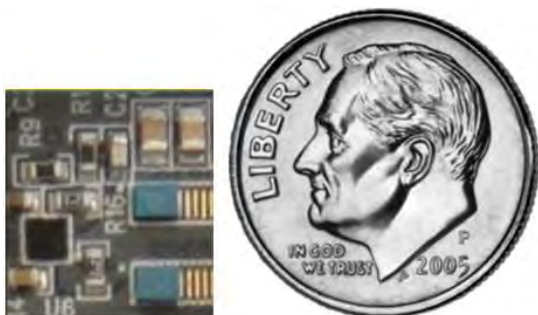
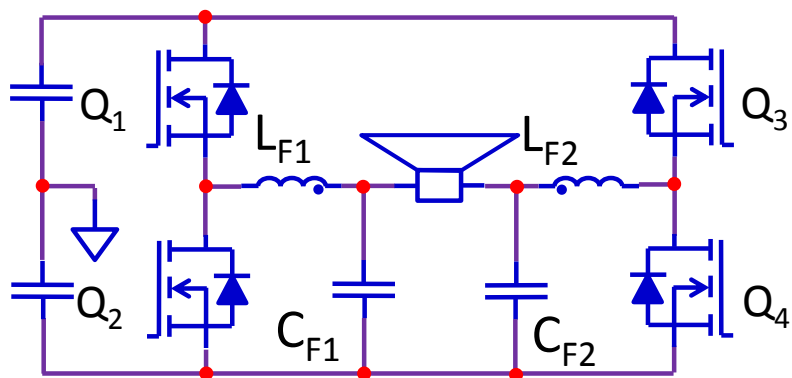
Courtesy of OmniPulse

Class-D Audio

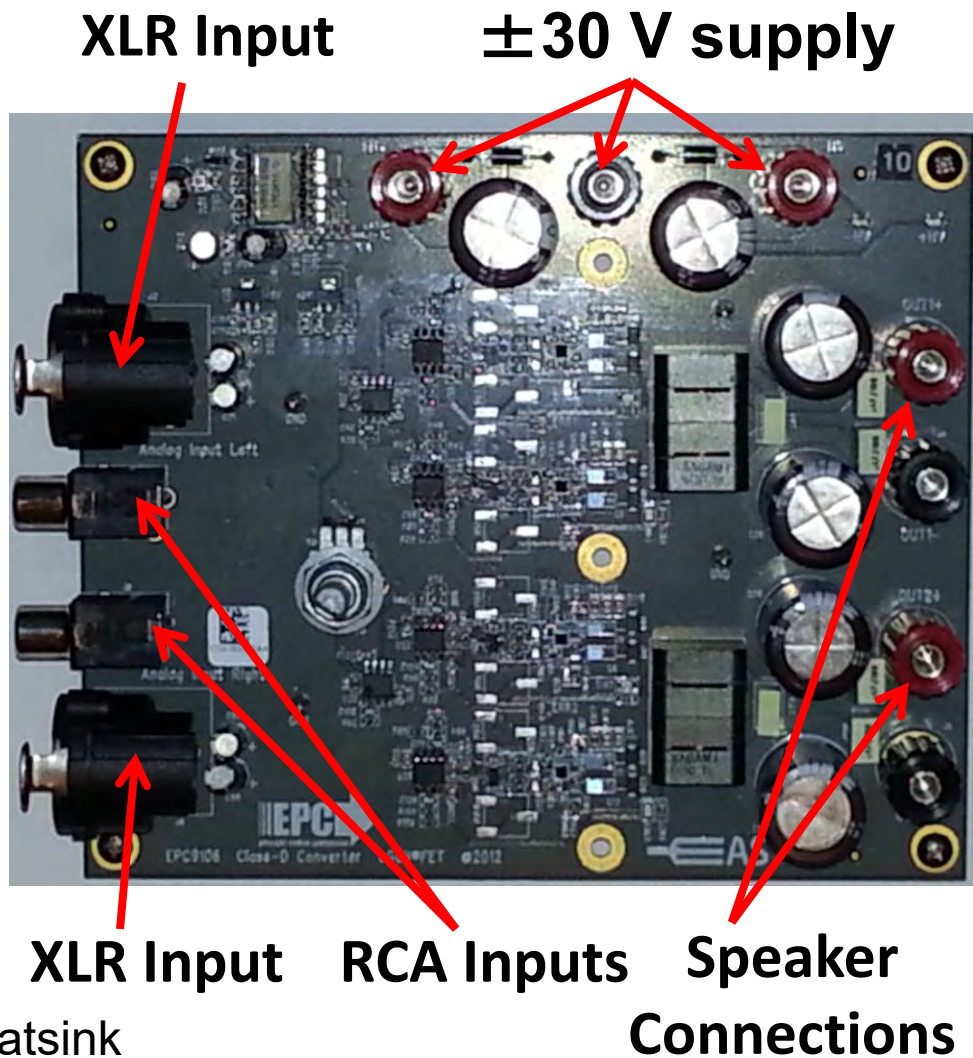
- Low $R_{DS(on)}$ & Low C_{OSS}
 - + High Efficiency
 - + High Damping Factor = Low open loop output Impedance = **Low T-IMD**
- Fast Switching & No Reverse Recovery (Q_{rr})
 - + High output linearity, Low Cross-over Distortion = **Low THD**



- Bridge-Tied-Load (BTL)
- EPC2016 with LM5113



eGaN FET Power Stage:
250 W into 4 Ω at 440 kHz without a heatsink

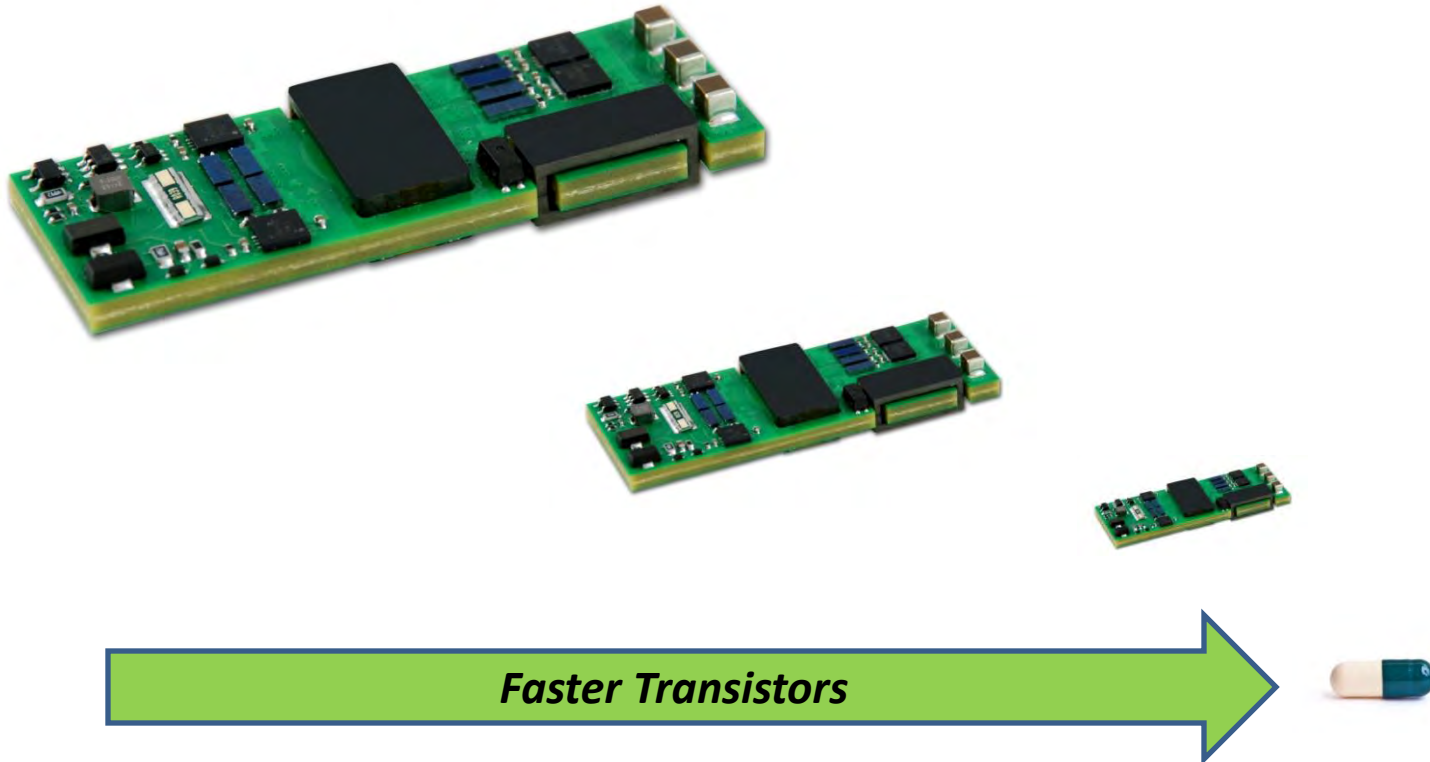


A Look Into the Future

- Does it enable significant new capabilities?
- Is it easy to use?
- Is it VERY cost effective to the user?
- Is it reliable?

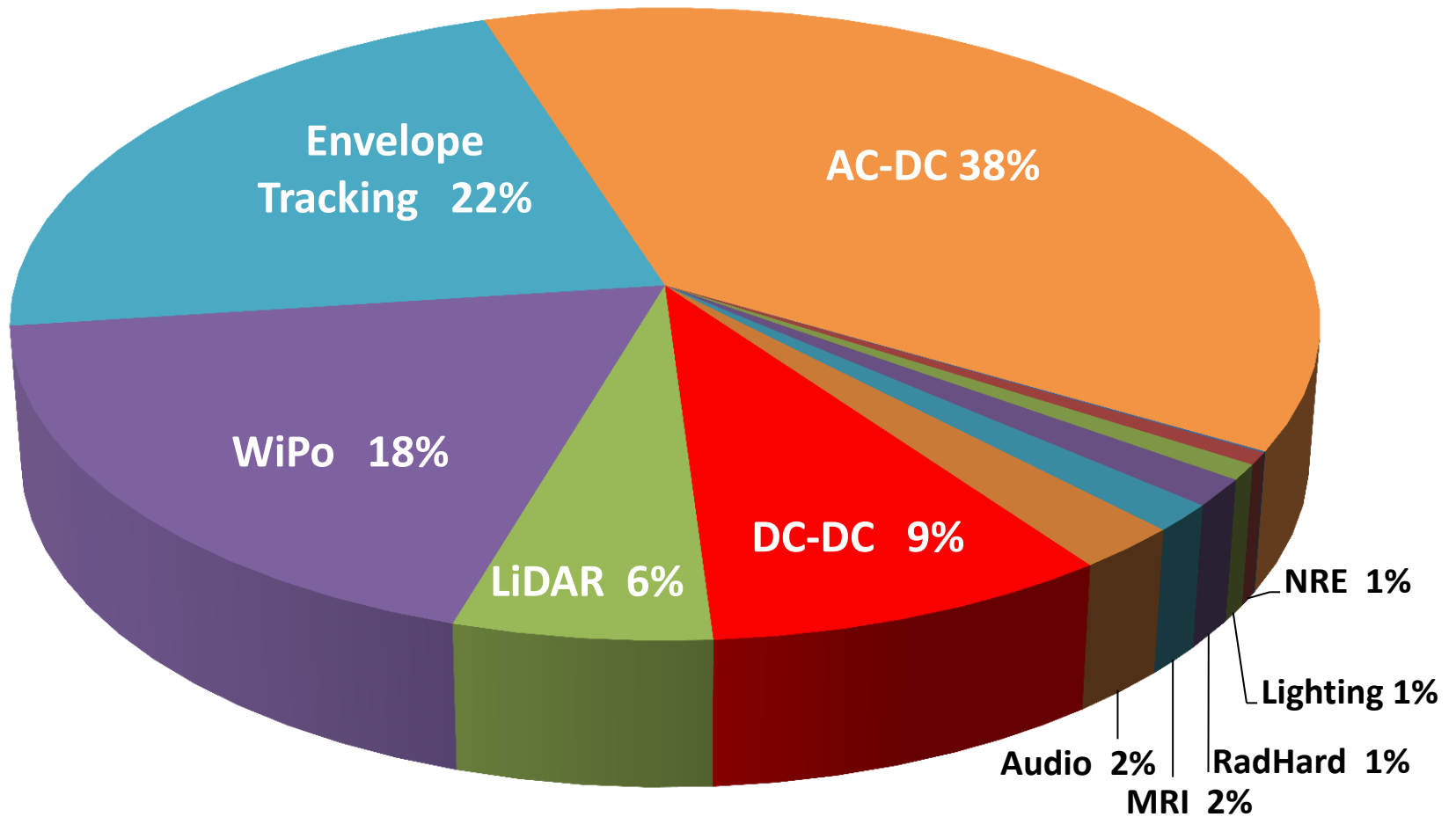
- Does it enable significant new capabilities?
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eGaN FETs are Faster



Faster transistors enable the systems to get smaller, more efficient, and lower cost.

- Wireless Power Transmission
- RF DC-DC “Envelope Tracking”
- LiDAR
- RadHard
- Network and Server Power Supplies
- Point of Load Modules
- Energy Efficient Lighting
- Class D Audio
- Various Medical



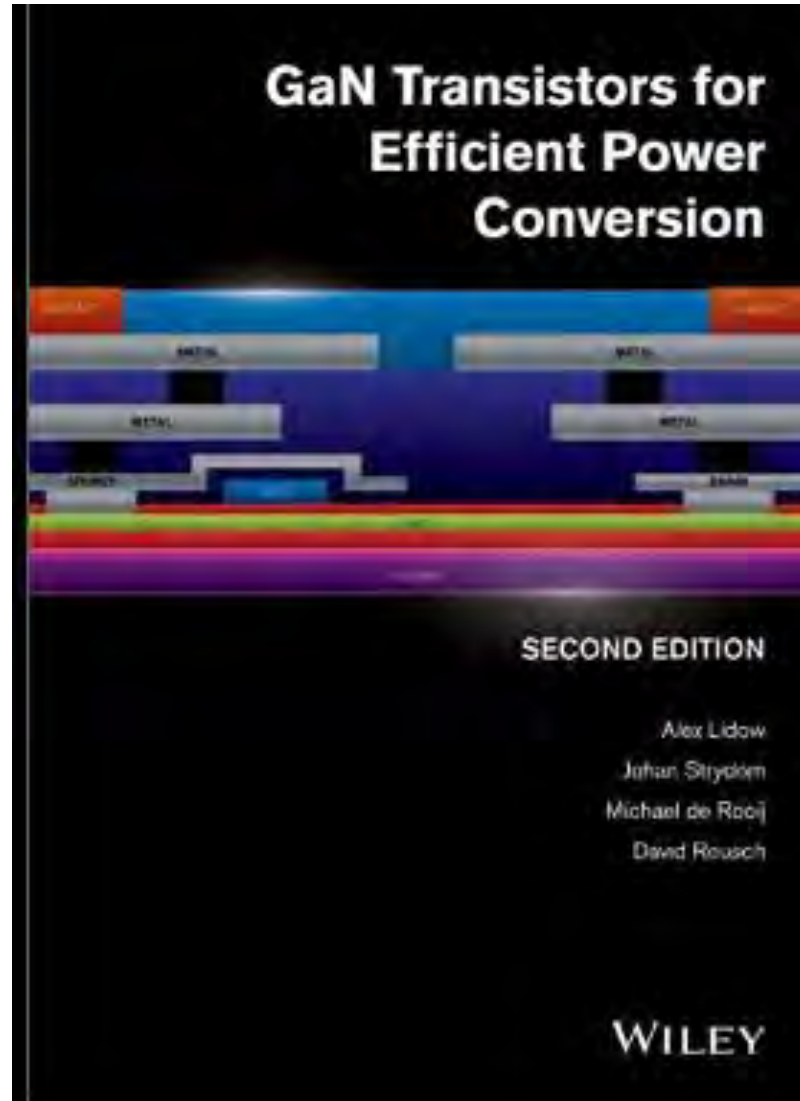
- Does it enable significant new capabilities?
- **Is it easy to use?**
- Is it VERY cost effective to the user?
- Is it reliable?

It's just like a MOSFET

except

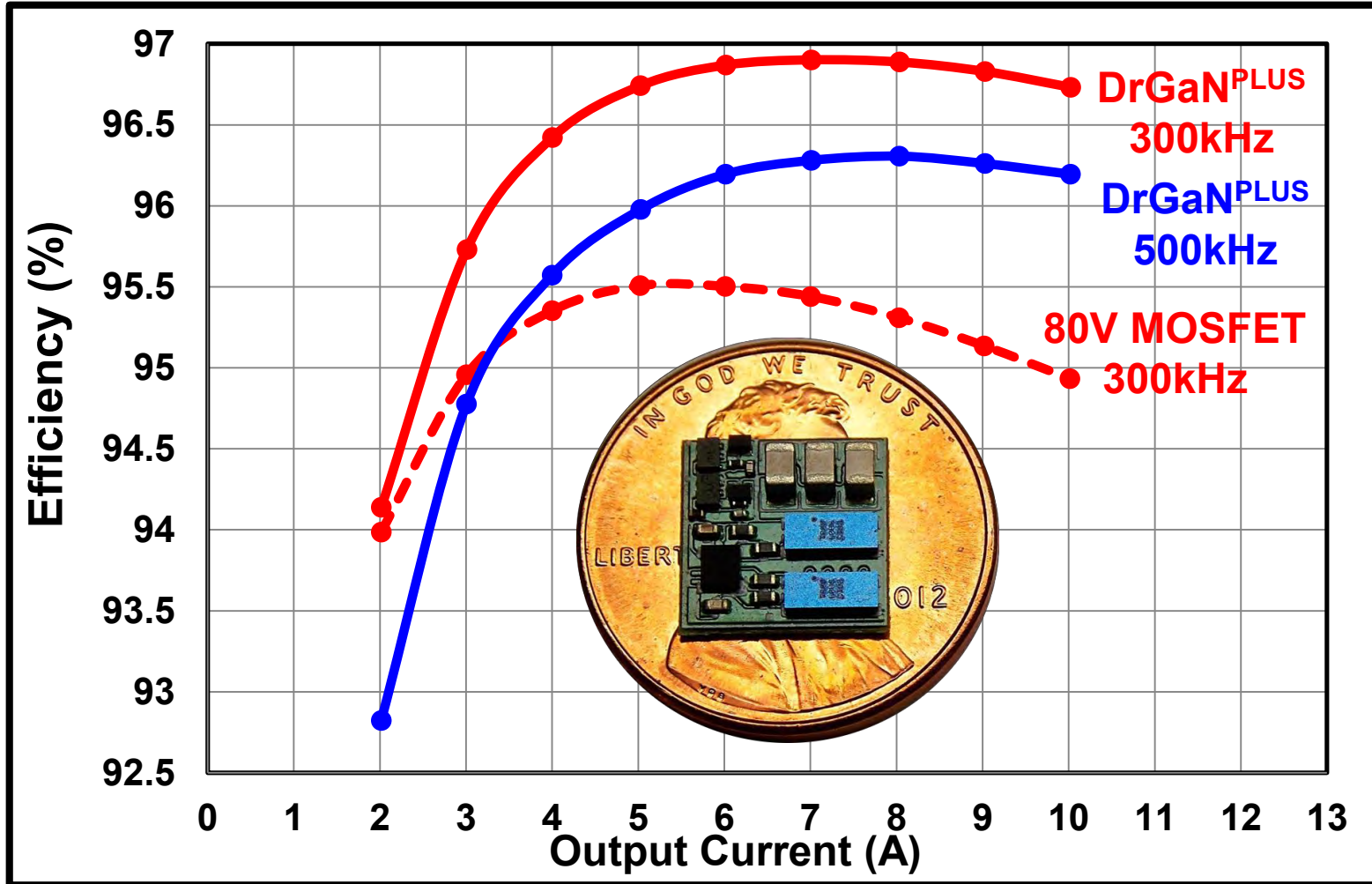
The high frequency capability makes circuits using eGaN FETs sensitive to layout

The lower $V_{G(MAX)}$ of 6 V makes it advisable to have V_{GS} regulation in your gate drive circuitry



Universities all over the world are graduating well-trained engineers experienced in the use of GaN Transistors

- Virginia Tech
- University of California at Santa Barbara
- Rensselaer Polytechnic Institute
- Hong Kong University of Science and Technology
- Cornell University
- Katholieke Universiteit Leuven
- University of Bristol
- University of Glasgow
- University of Sheffield
- University of Warsaw
- University of Sydney
- Massachusetts Institute of Technology
- Cambridge University
- National Central University of Taiwan
- National Taiwan University
- Chang Gung University
- University of Florida
- Florida State University
- Case Western University
- Yale University
- University of Ohio, Toledo
- Ohio State University
- Kyushu Institute of Technology
- National Chiao Tung University
- University of Tennessee
- Auburn University
- University of Texas
- Yamaguchi University
- Universitat Kassel
- National Tsinghua University
- Mid Sweden University
- New Mexico State University
- University of Johannesburg
- University of Toronto
- Universita di Padova
- Delft University of Technology
- Missouri University of Science and Technology
- University of Maryland
- Insitituto Italiano di Technologia



$V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $f_{sw}=300\text{ kHz}$ $L=10\text{ }\mu\text{H}$ eGaN FET T/SR: 100 V EPC2001
MOSFET T/SR: 80 V BSZ123N08NS3G

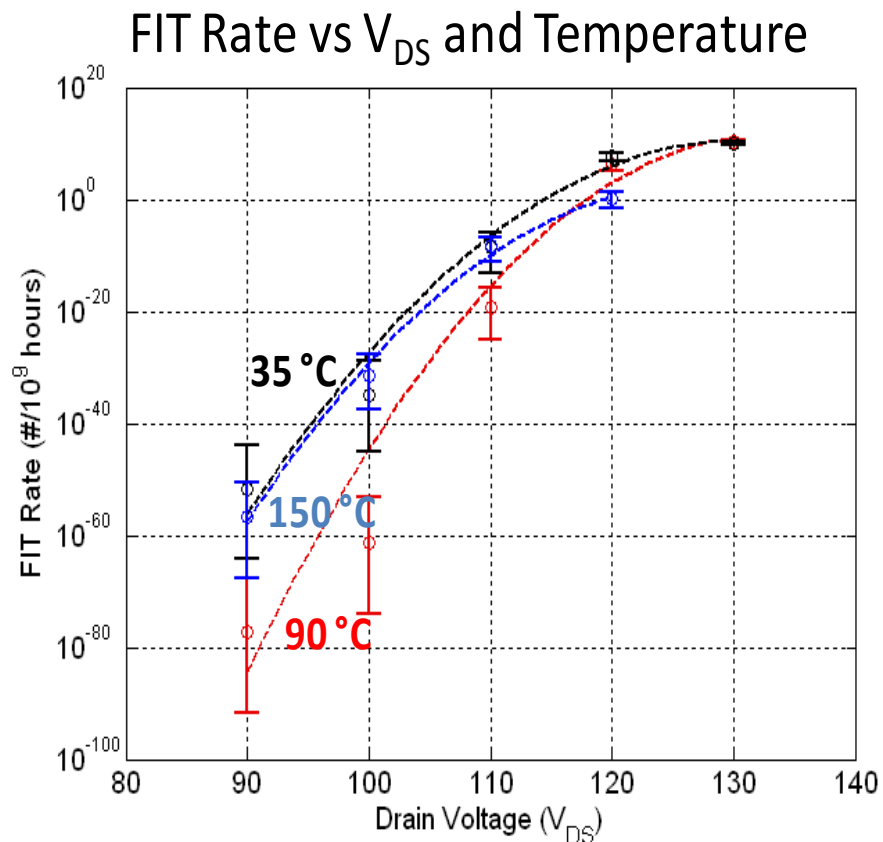
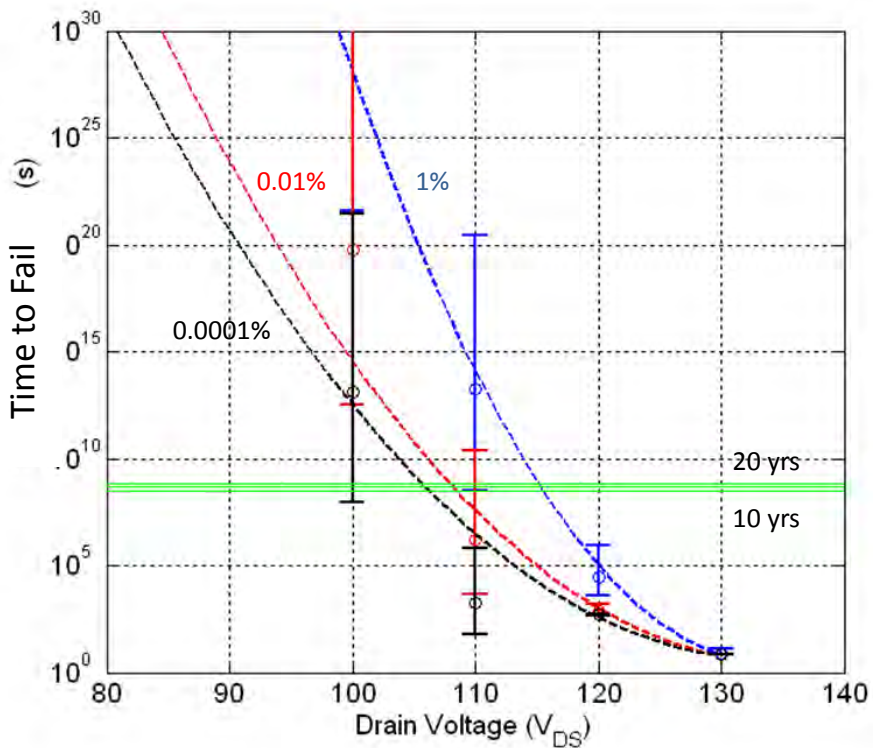
- Does it enable significant new capabilities?
- Is it easy to use?
- Is it **VERY** cost effective to the user?
- Is it reliable?

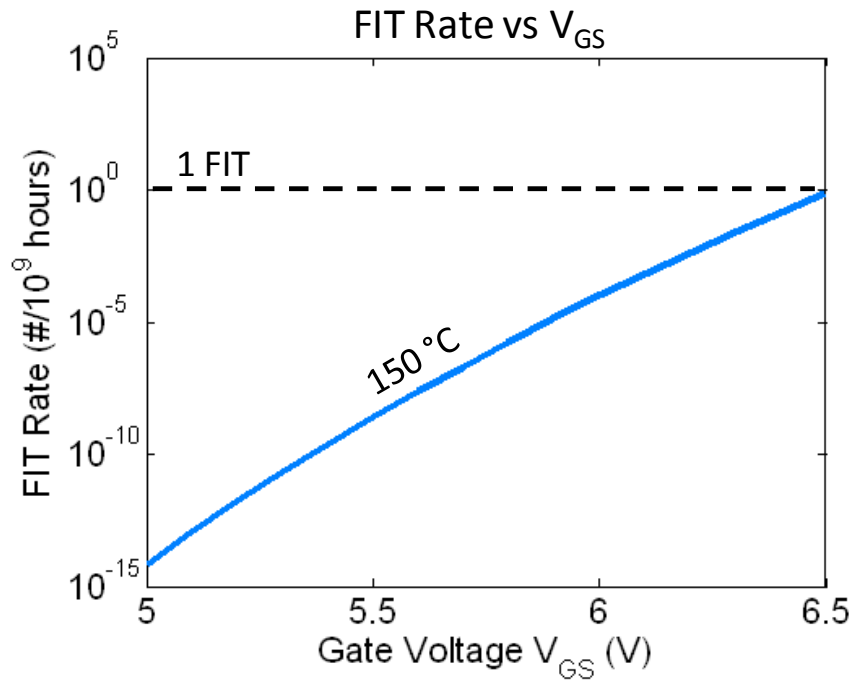
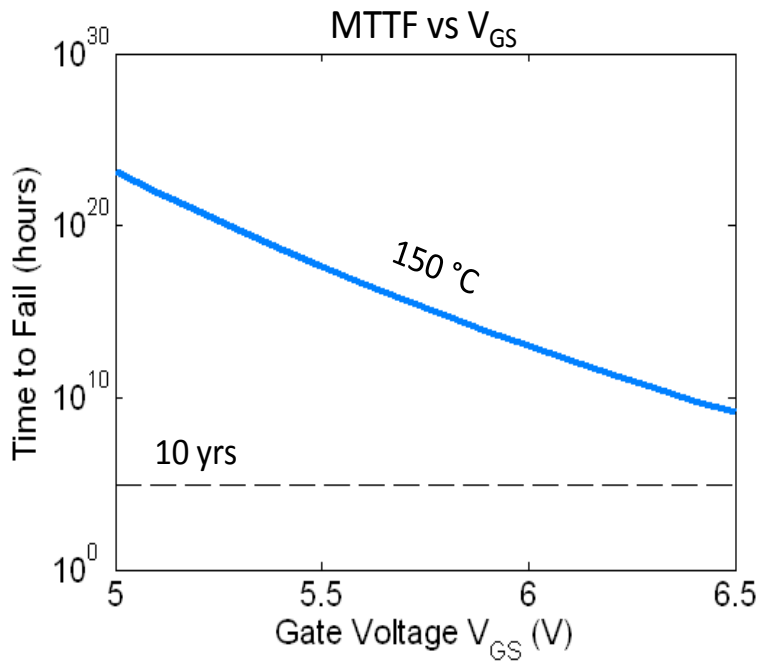
	2014	2015
Starting Material	lower	lower
Epi Growth	<i>higher</i>	<i>~same?</i>
Wafer Fab	same	lower
Test	same	same
Assembly	lower	lower
OVERALL	higher	<i>lower!</i>

- Does it enable significant new capabilities?
- Is it easy to use?
- Is it VERY cost effective to the user?
- **Is it reliable?**

Part Number	Stress V_{DS} (V)	Temperature ($^{\circ}C$)	Sample Size	Results (# of fails)	Duration (Hrs)
EPC2001	80	150	207	0	500
EPC2001	80	150	144	0	168
EPC2001	80	150	80	0	1000
EPC2001	80	125	96	0	168
EPC2001	100	125	45	0	1000
EPC2016	80	150	239	0	500
EPC2016	100	150	80	0	168

- Over 0.5 million accumulated device hours of reliability testing without failure across 891 devices.

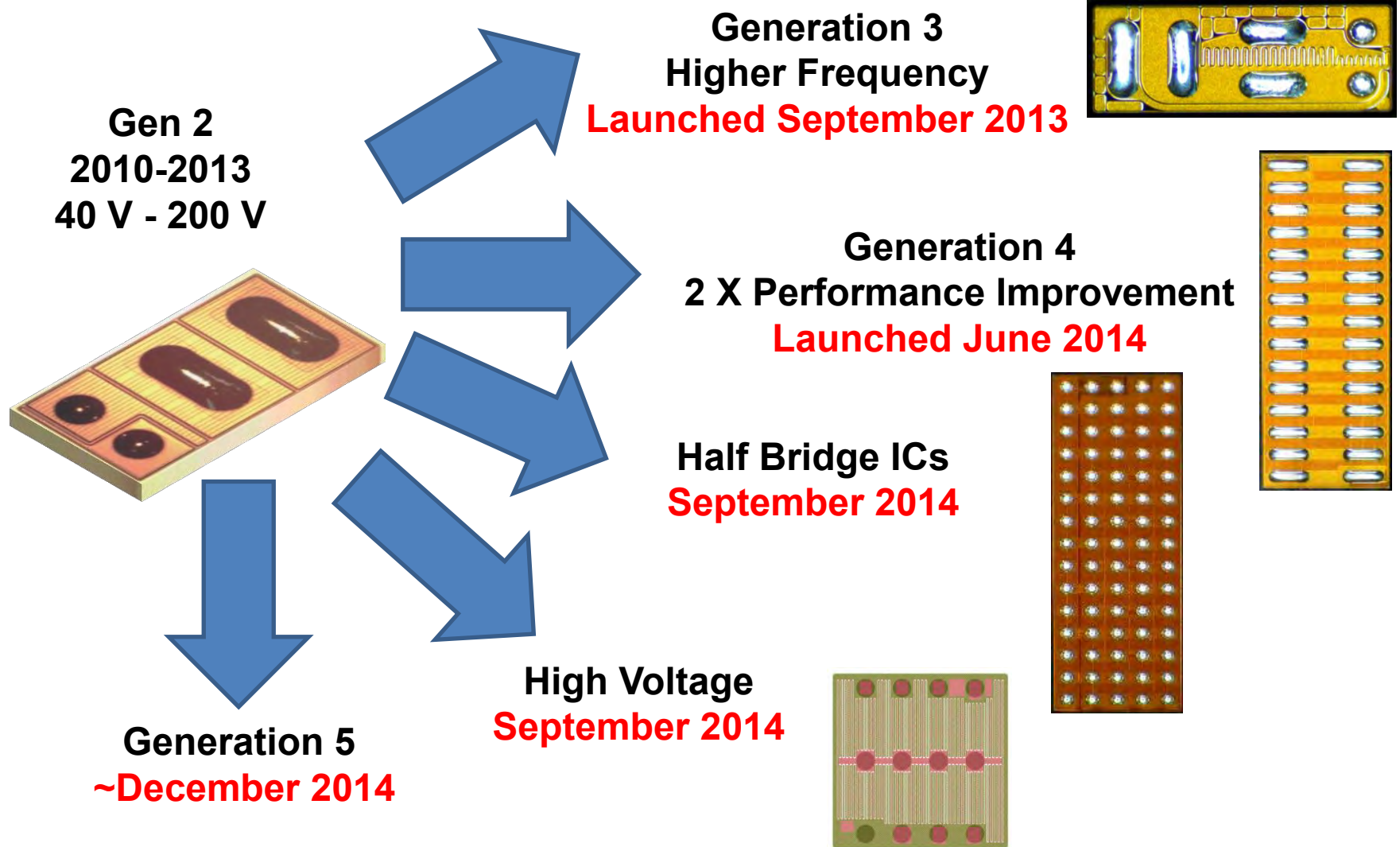




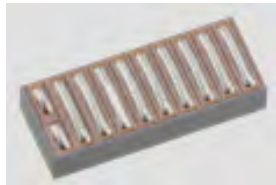
Part Number	Stress V_{GS} (V)	Temperature ($^{\circ}C$)	Sample Size	Results (# of fails)	Duration (Hrs)
EPC2001	5	150	48	0	168
EPC2001	5	125	167	0	168
EPC2001	5	150	192	0	500
EPC2001	5	150	125	0	1000
EPC2014	5	150	48	0	500
EPC2015	5	125	96	0	168
EPC2015	5	150	50	0	1000
EPC2001	5.5	150	48	0	168
EPC2001	5.5	150	208	0	500
EPC2016	5.5	150	80	0	168
EPC2016	5.5	150	80	0	500
EPC2001	5.75	150	96	0	168
EPC2001	5.75	125	32	0	168
EPC2001	5.75	125	48	0	181
EPC2001	5.75	125	64	0	200
EPC2001	5.75	150	240	0	500
EPC2001	5.75	125	32	0	500
EPC2016	5.75	90	32	0	200
EPC2016	5.75	150	32	0	350
EPC2016	5.75	150	240	0	500
EPC2019	5.75	150	160	0	168
EPC2001	6	125	24	0	181
EPC2001	6	150	32	0	200
EPC2001	6	150	80	0	437
EPC2001	6	150	32	0	500
EPC2001	6	125	32	0	500
EPC2016	6	90	32	0	200
EPC2016	6	150	32	0	350
EPC2001	6.3	150	32	0	200
EPC2016	6.3	150	32	0	200
EPC2016	6.3	90	32	0	200
EPC2016	6.6	150	32	0	200

- 0 fail in over 0.97 million accumulated device hours of HTGB reliability testing greater than 5V.
- 0 fail in over 0.6 million accumulated device hours of HTGB reliability testing greater than 5.5V.

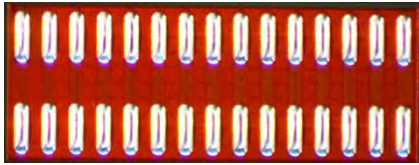
A Look Into the Future



Generation 2/4 Discrete HB

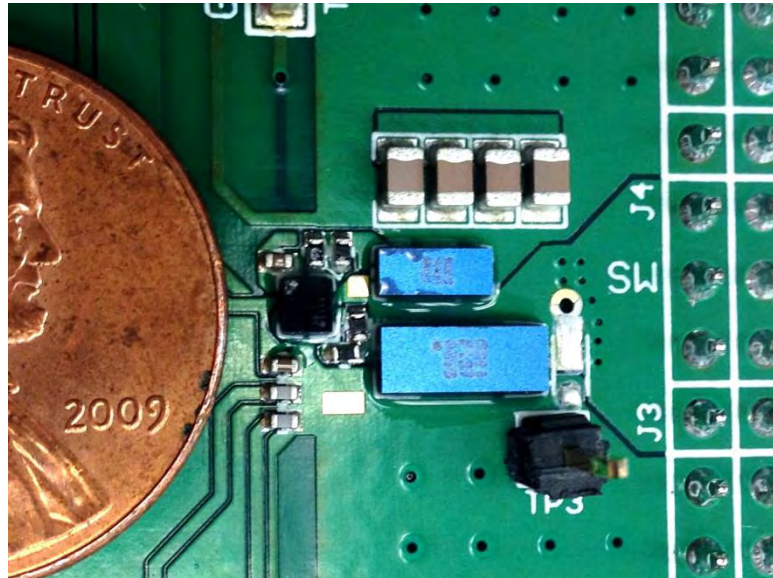


+

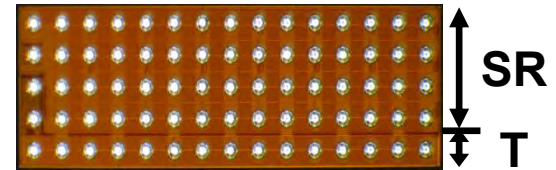


Top Switch (T)

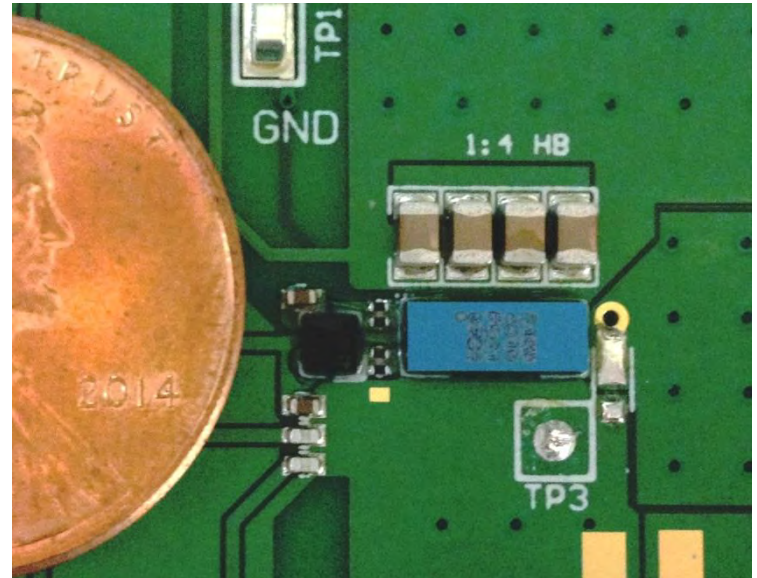
Synchronous Rectifier (SR)



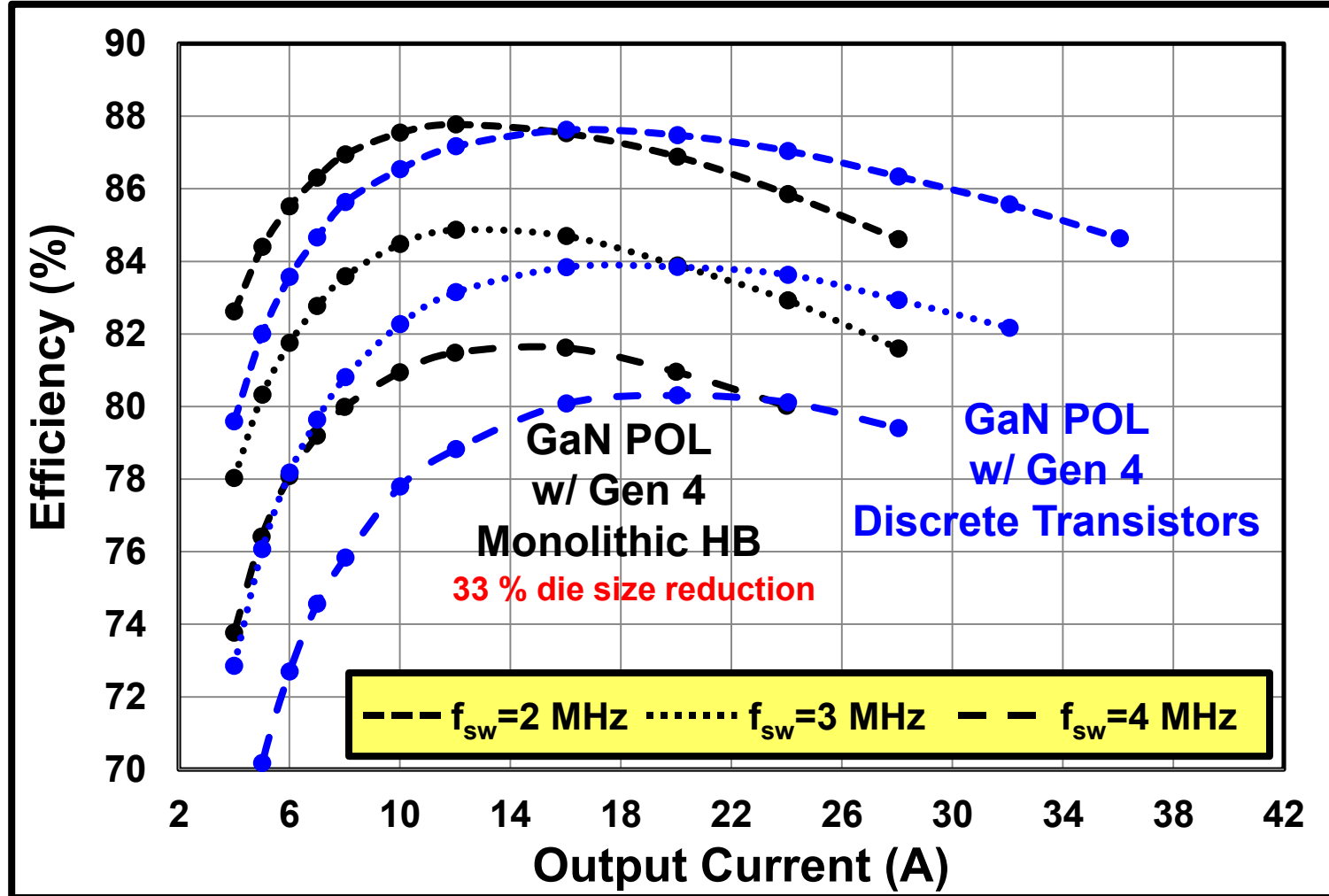
Generation 4 Monolithic 4:1 HB



33 % die size reduction



Monolithic Half Bridge



$V_{IN}=12\text{ V}$ $V_{OUT}=1.2\text{ V}$ $L=100\text{ nH}$

- GaN transistors enable exciting new applications such as LiDAR, RF Envelope Tracking and Wireless Power Transmission
- GaN transistors have the potential to replace silicon power MOSFETs and LDMOS in power conversion applications with a low-cost and higher efficiency solution
- GaN technology is keeping Moore's Law alive!